



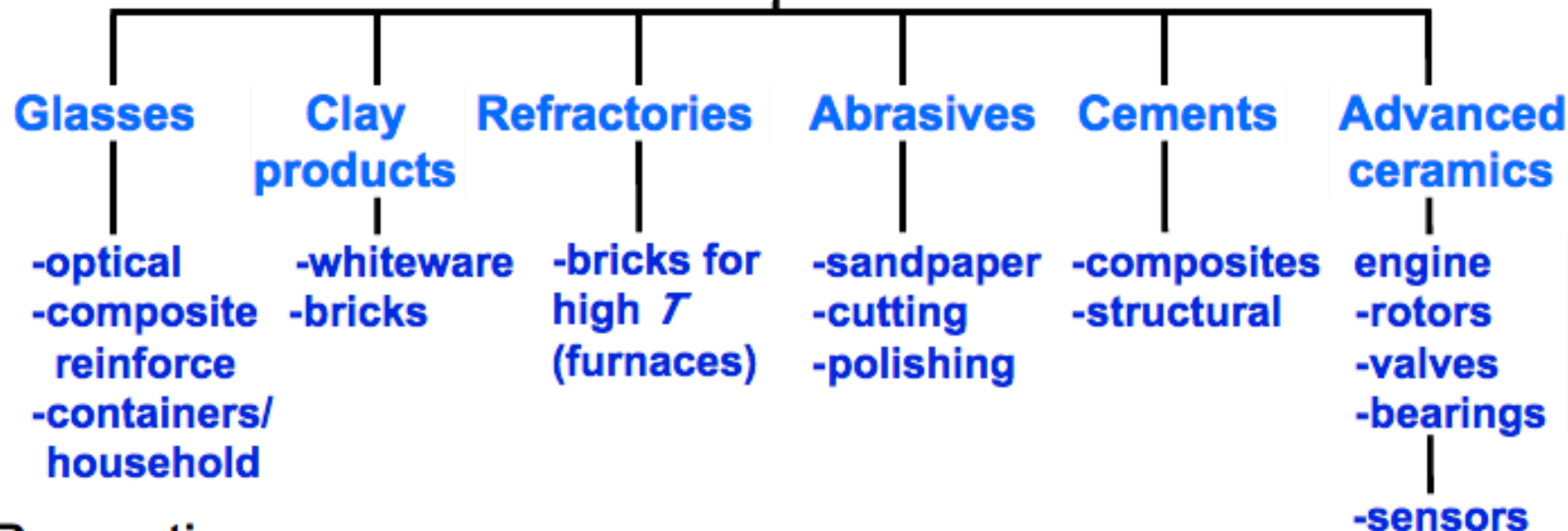
Università degli Studi di Trieste
Dipartimento di Ingegneria ed Architettura

Scienza e tecnologia dei materiali ceramici

Prof. Valter Sergo

Contributi di:
Federico Antonelli
Elisa Favero
Silvia Dalla marta

Taxonomy of Ceramics

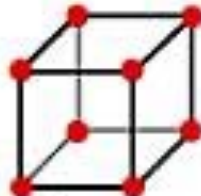


- Properties:
 - T_m for glass is moderate, but large for other ceramics.
 - Small toughness, ductility; large moduli & creep resist.
- Applications:
 - High T , wear resistant, novel uses from charge neutrality.
- Fabrication
 - some glasses can be easily formed
 - other ceramics can not be formed or cast.

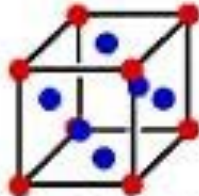
Packing of atoms determines structures

- Packing efficiency can be characterized by coordination number which depends on cation-anion radius ratio (r_c/r_a)

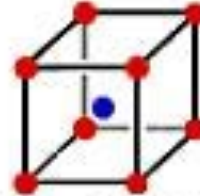
<i>Cation-anion radius ratio (r_c/r_a)</i>	< 0.155	$0.155 - 0.225$	$0.225 - 0.414$	$0.414 - 0.732$	$0.732 - 1.000$	> 1.000
<i>Coordination number</i>	2	3	4	6	8	12



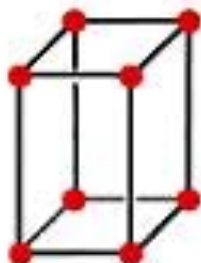
**Simple
cubic**



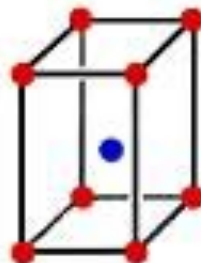
**Face-centered
cubic**



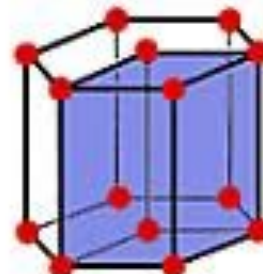
**Body-centered
cubic**



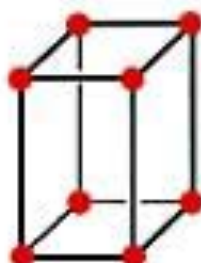
**Simple
tetragonal**



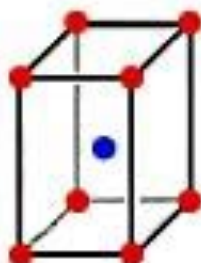
**Body-centered
tetragonal**



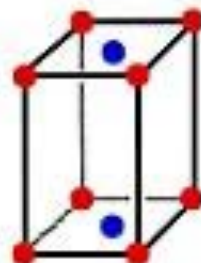
Hexagonal



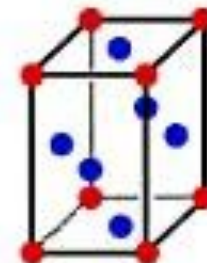
**Simple
orthorhombic**



**Body-centered
orthorhombic**



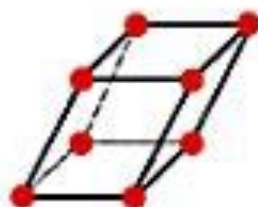
**Base-centered
orthorhombic**



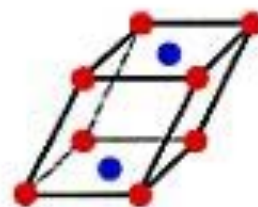
**Face-centered
orthorhombic**



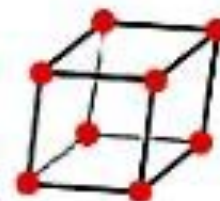
Rhombohedral



**Simple
Monoclinic**



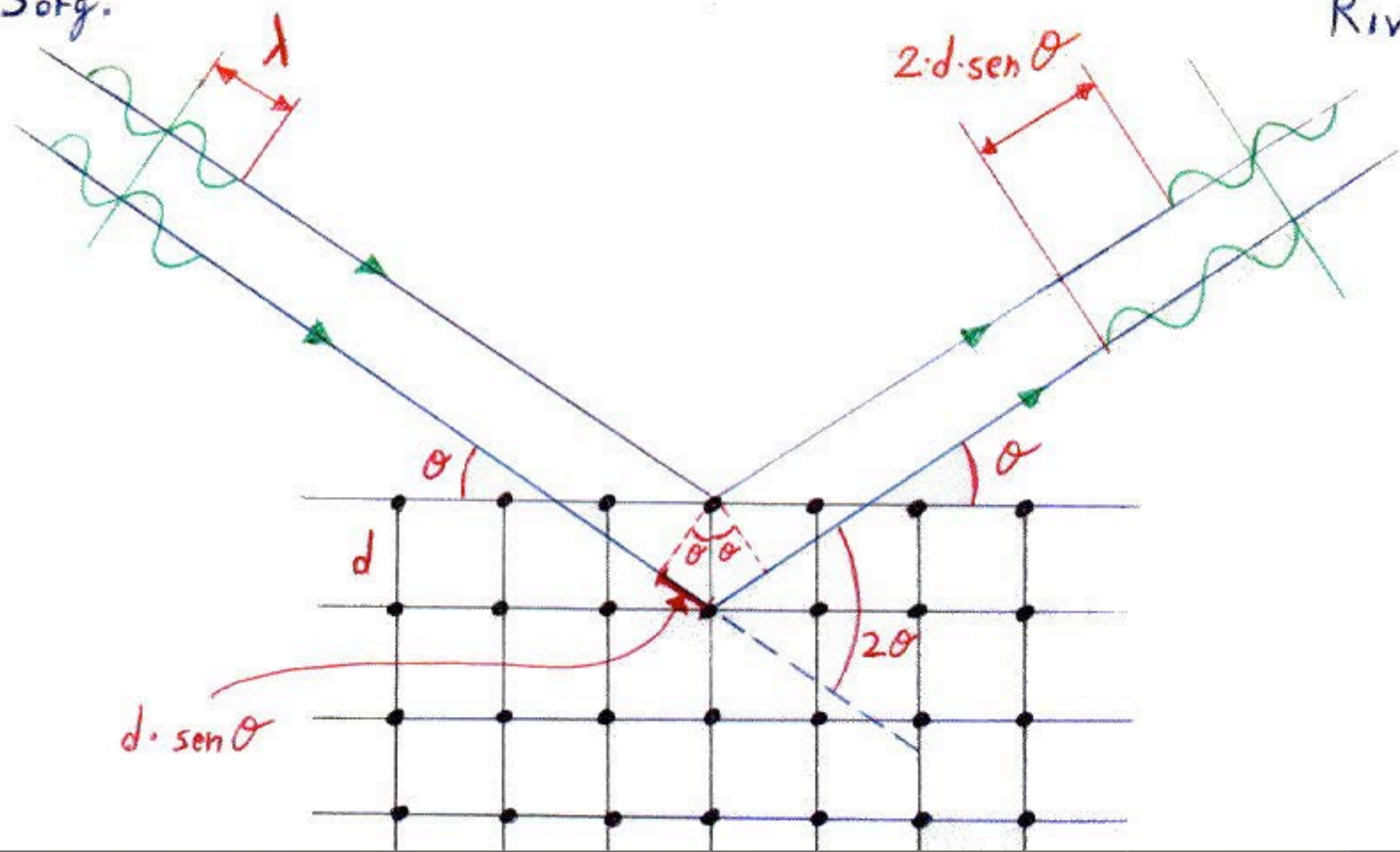
**Base-centered
monoclinic**

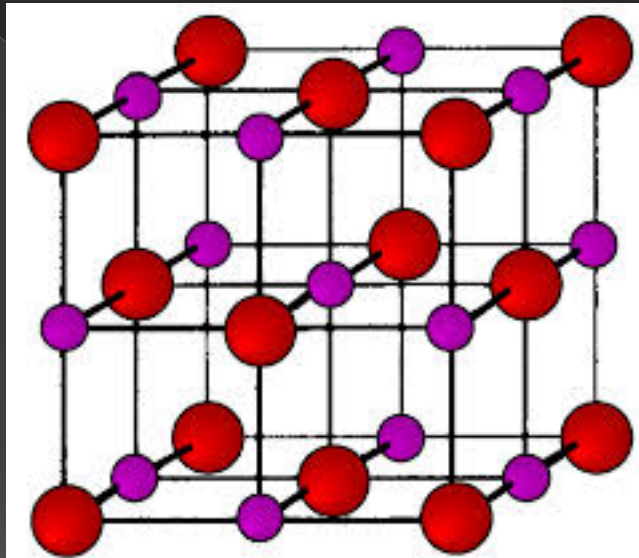


Triclinic

Sorg.

Riv.

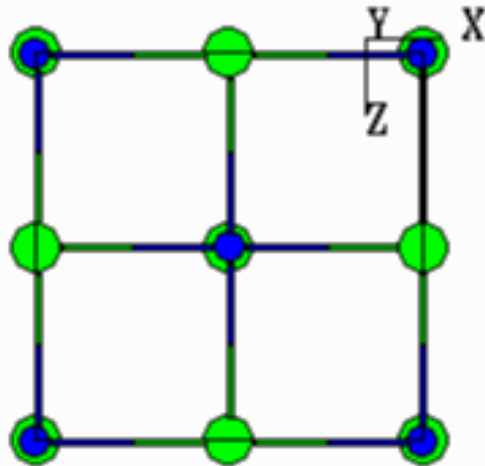




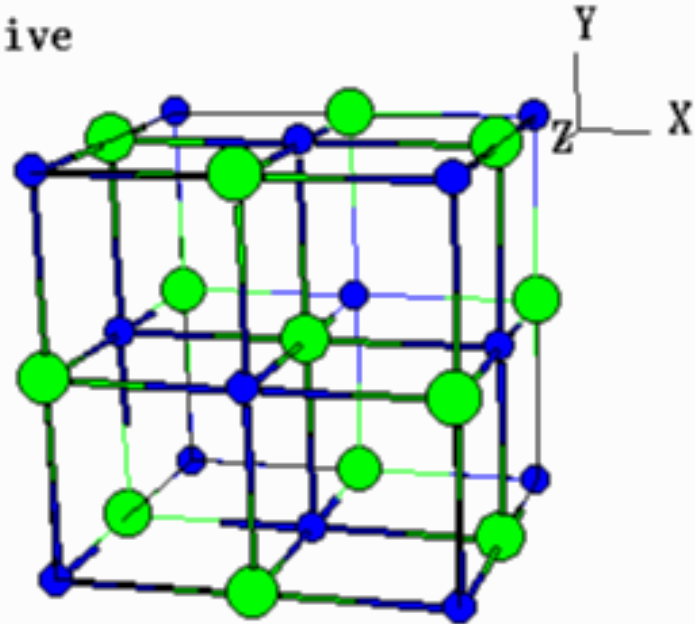
Rock Salt: MgO , CaO , NiO

ROCKSALT (NaCl)

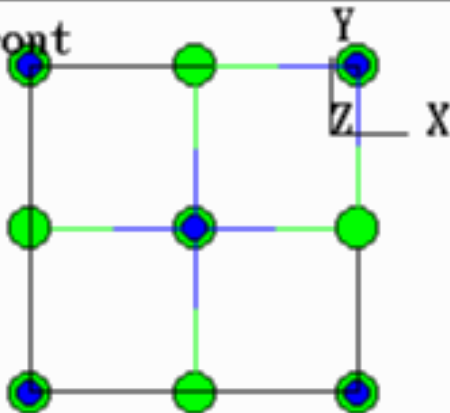
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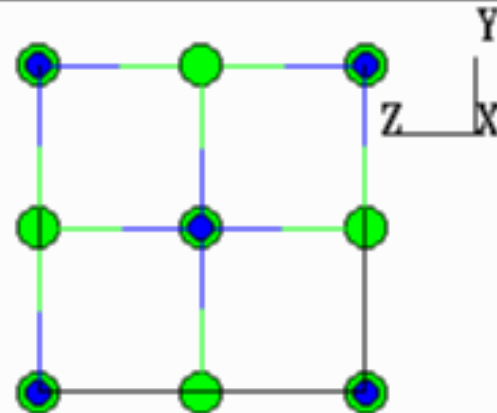
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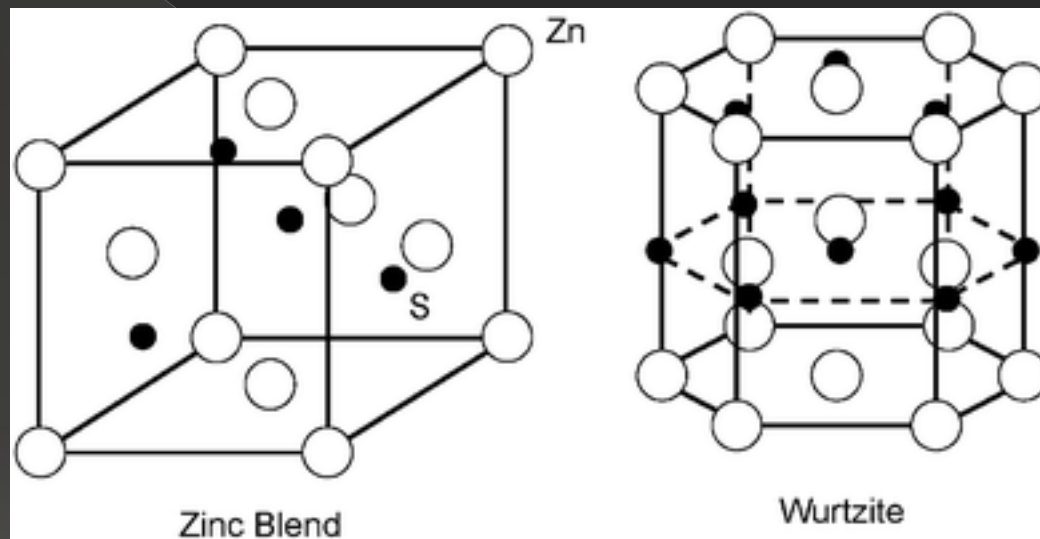


Front



Right

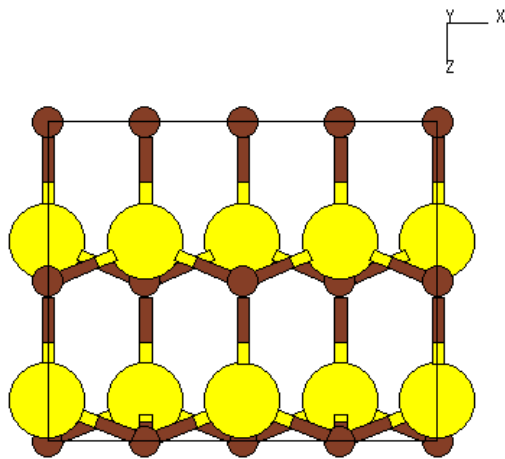




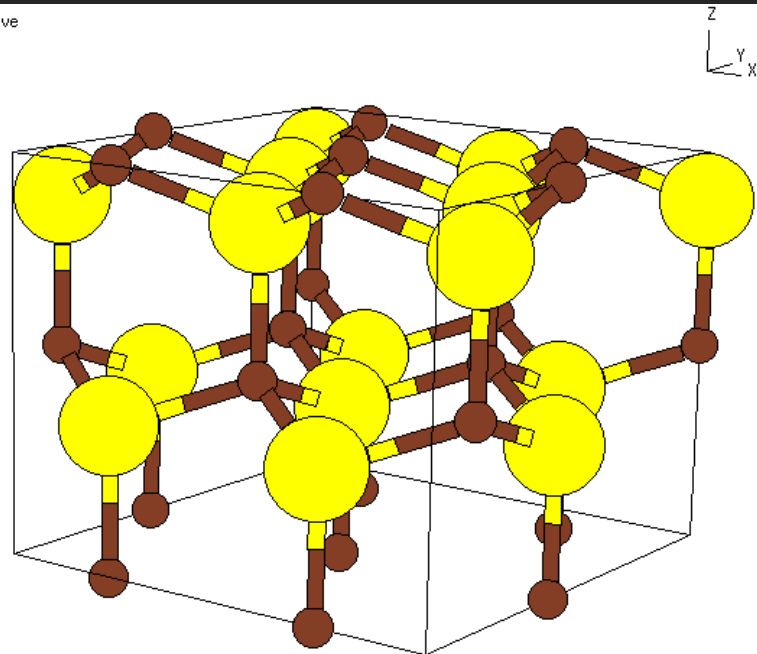
Zinc Blend and wurtzite: ZnO , SiC , BeO

WURTZITE $[(\text{Zn}, \text{Fe})\text{S}]$

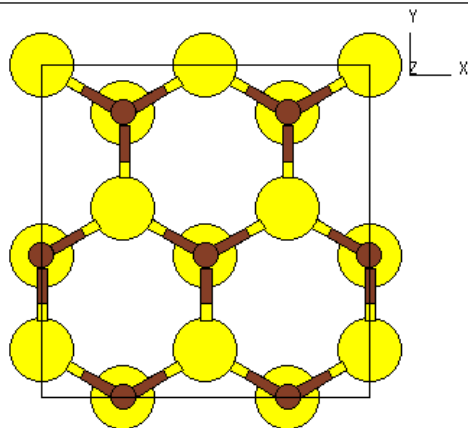
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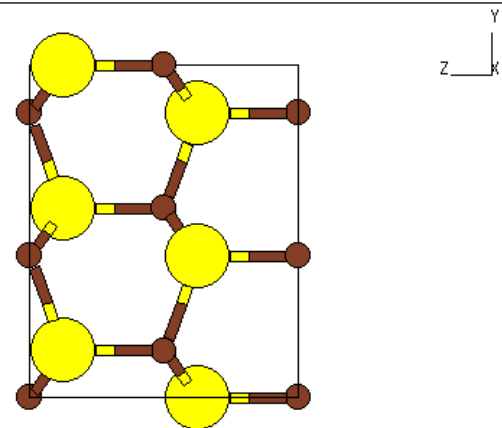
Active



Front

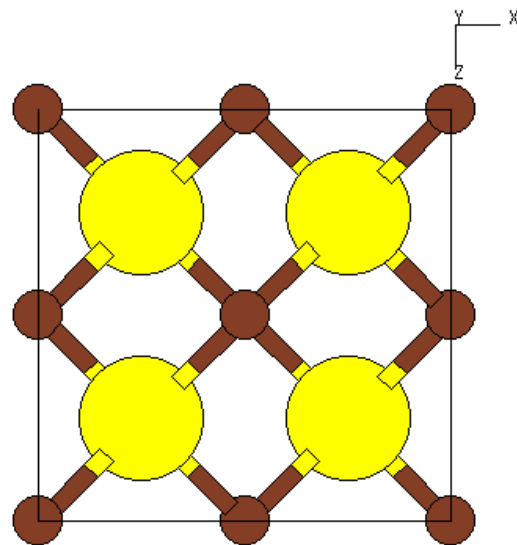


Right

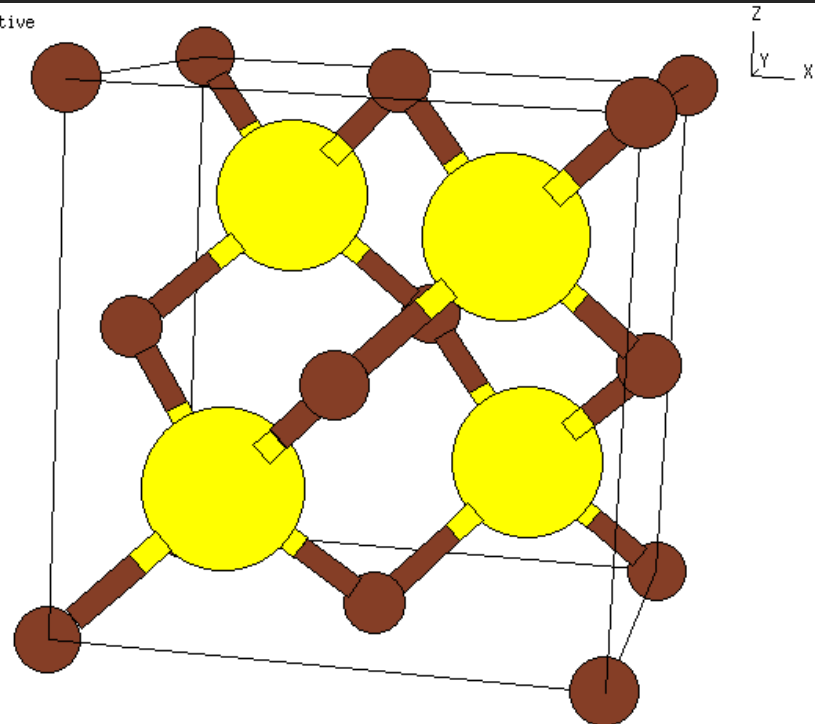


SPHALERITE $[(\text{Zn},\text{Fe})_2\text{S}]$

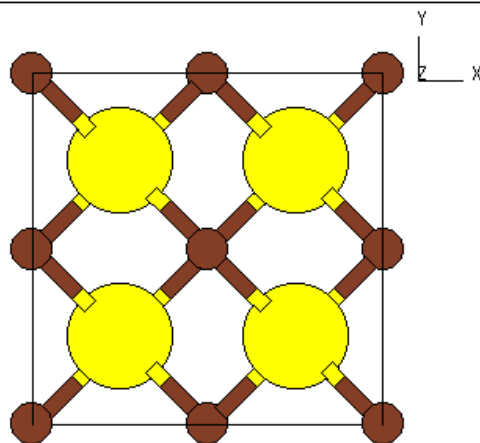
Top



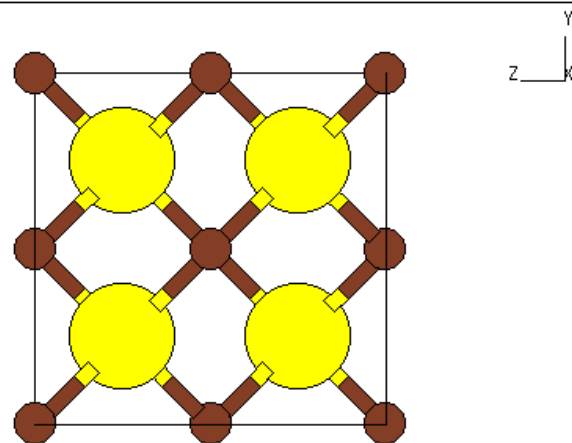
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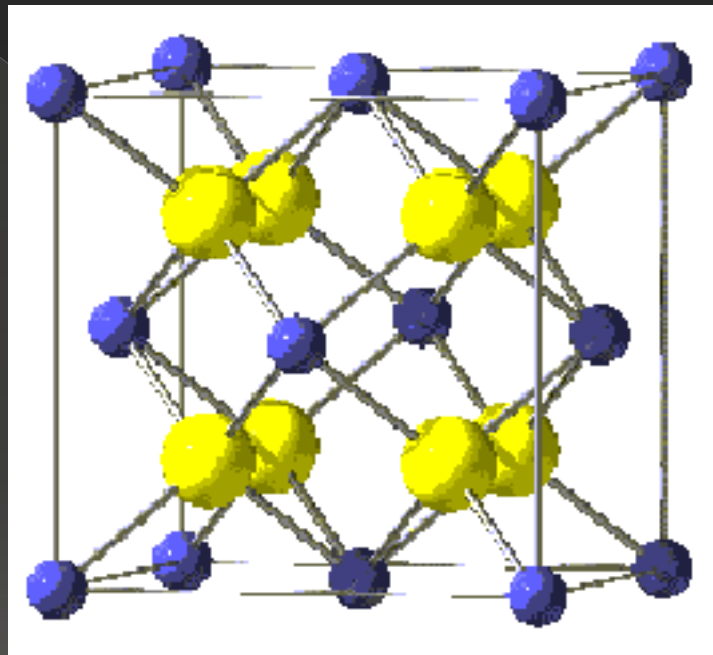


Front



Right

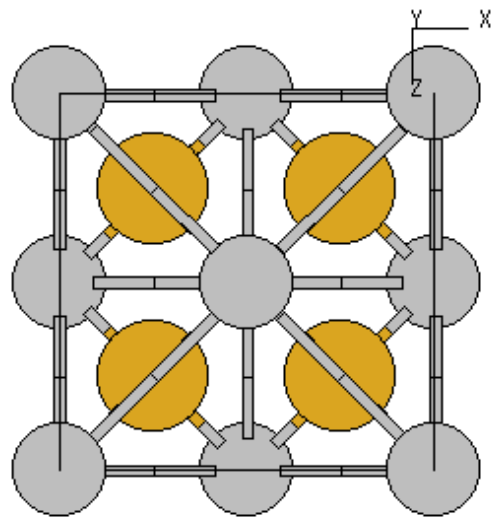




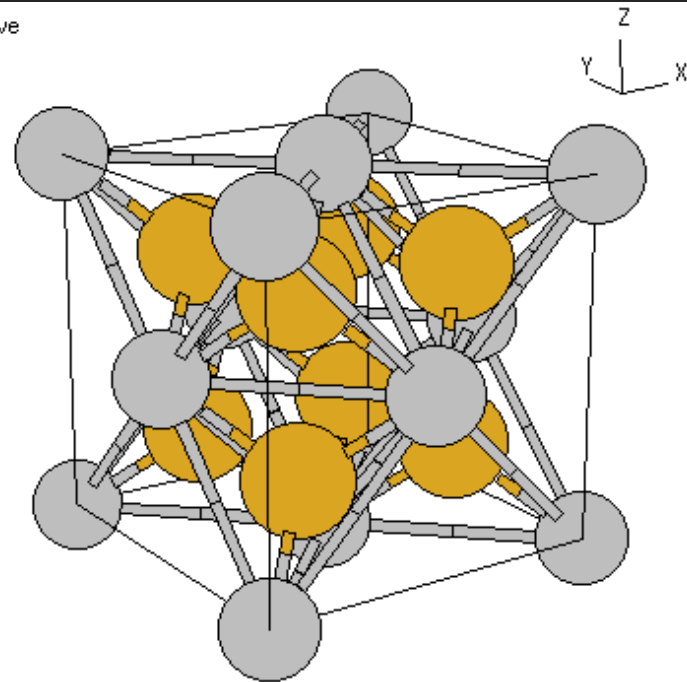
Fluoride structure: ZrO_2 , CeO_2 , UO_2

FLUORITE (CaF_2)

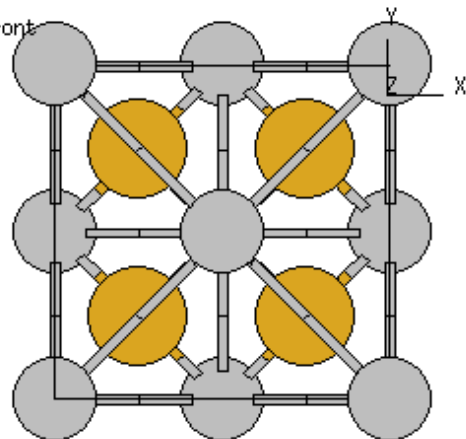
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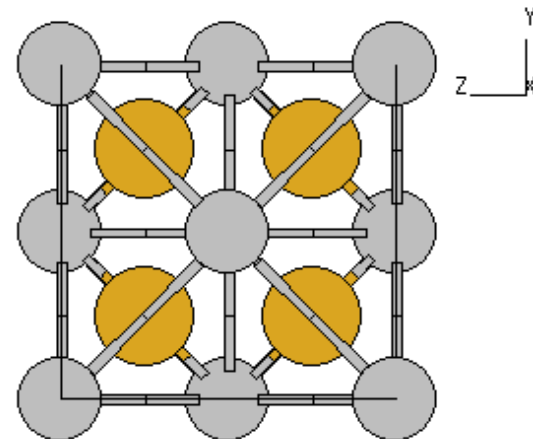
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Front

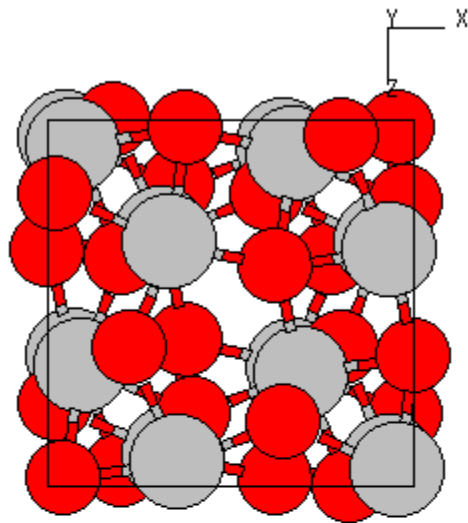


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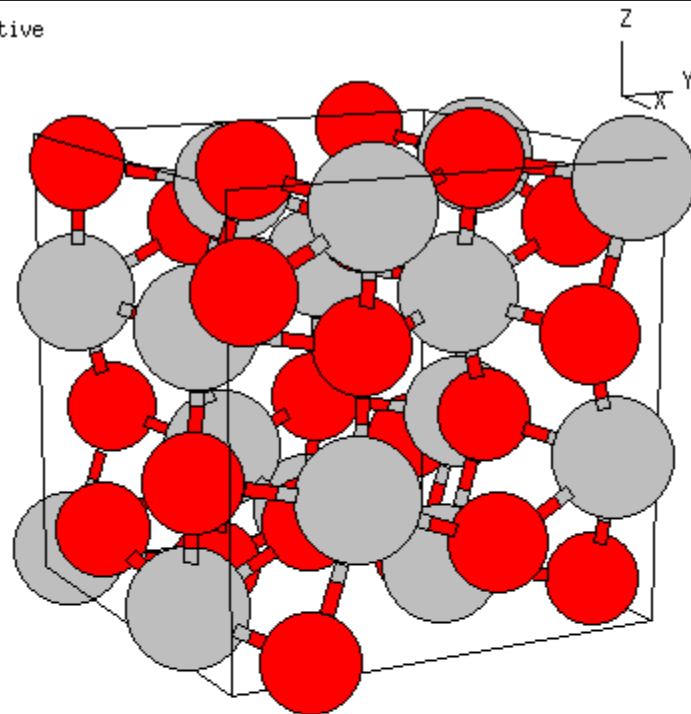


CORUNDUM ($\text{Al}_2\text{O}_3 - \alpha$)

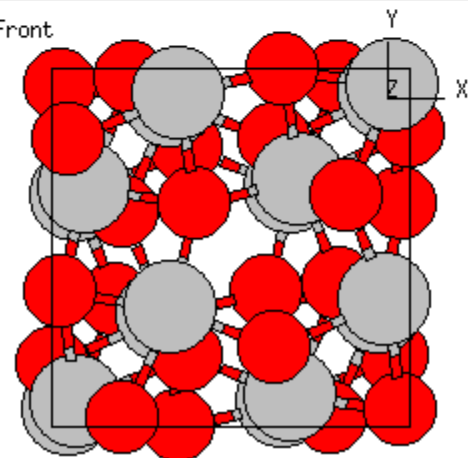
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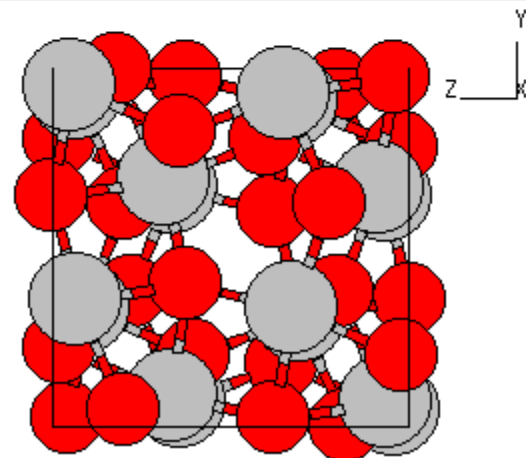
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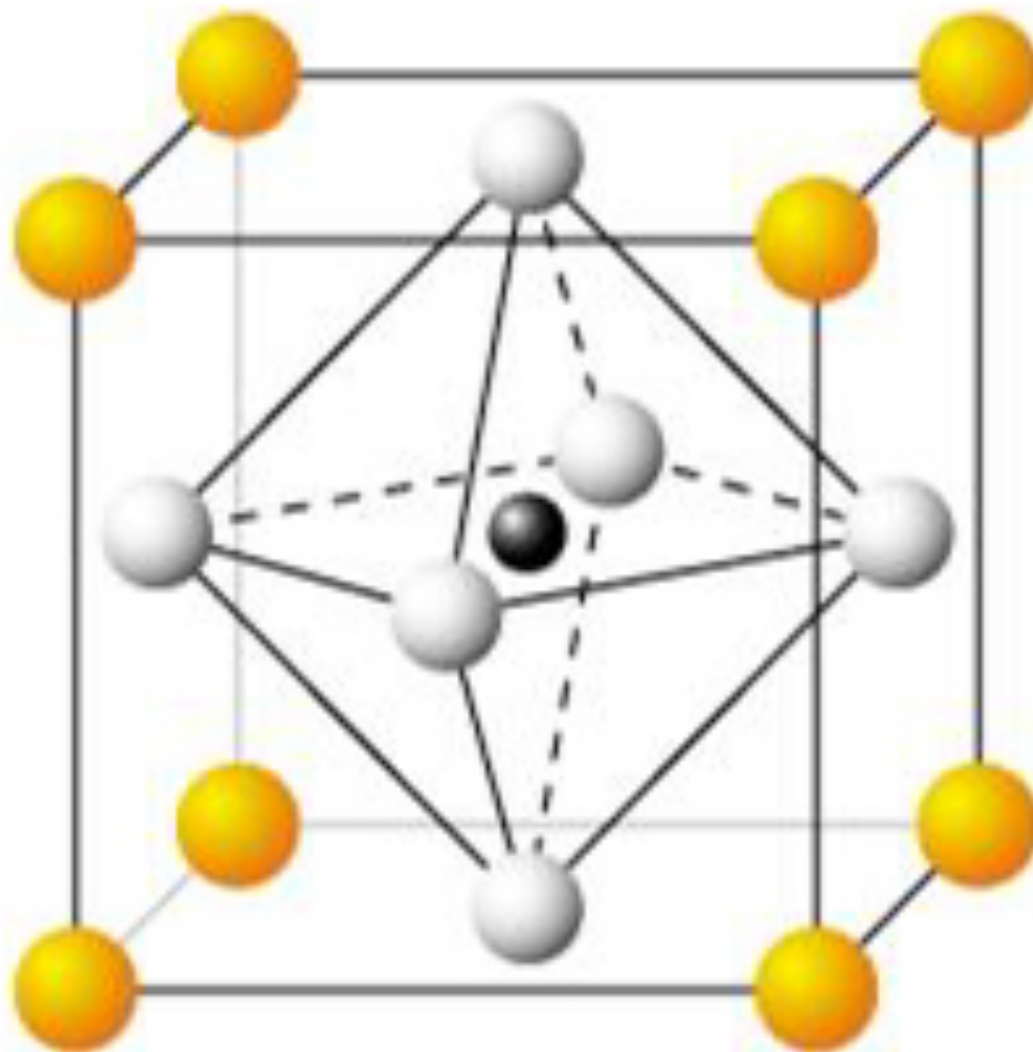


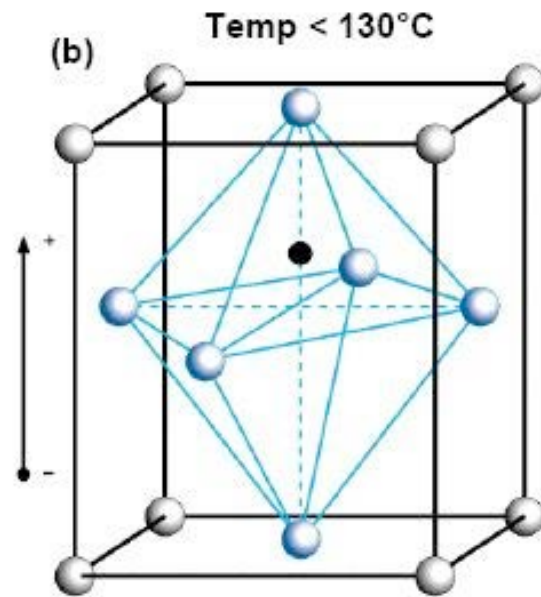
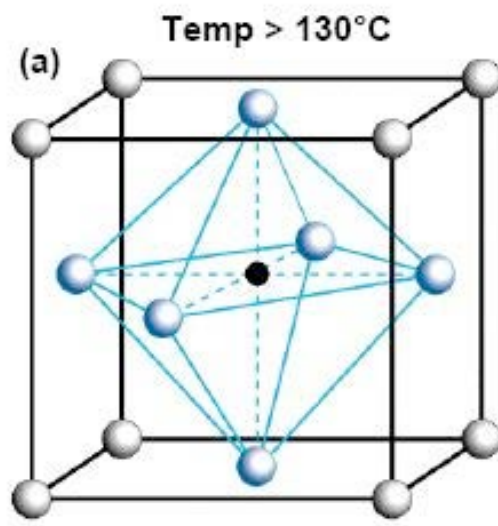
Front



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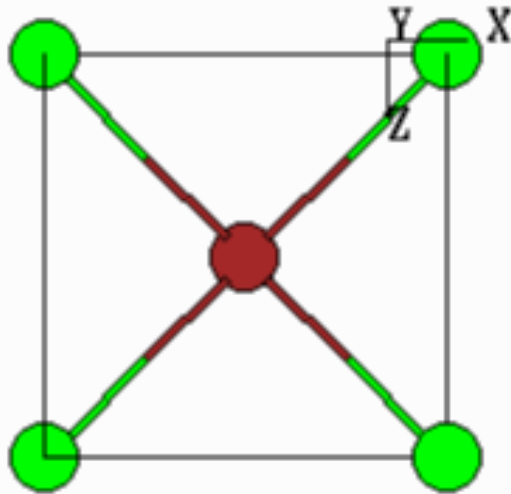




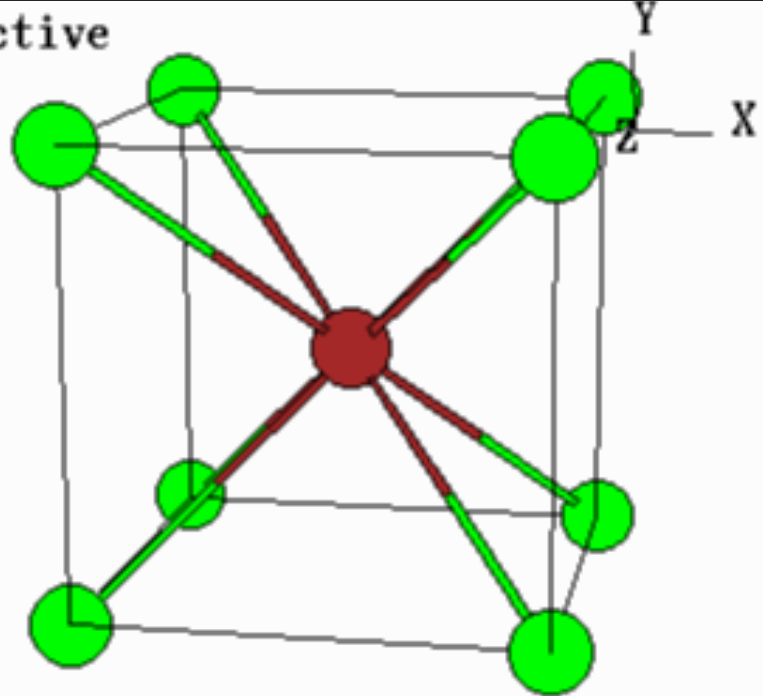


Cubic Body Centered

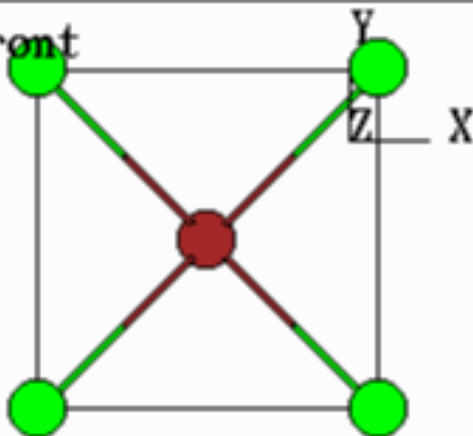
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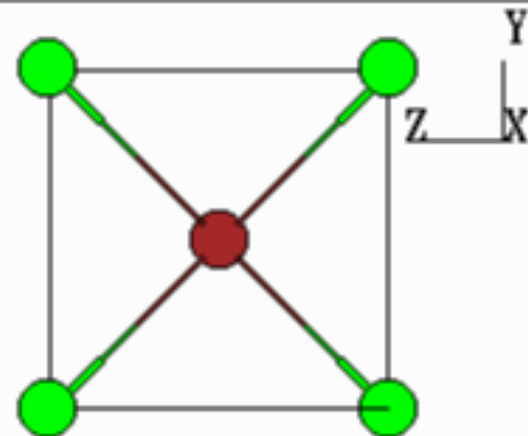
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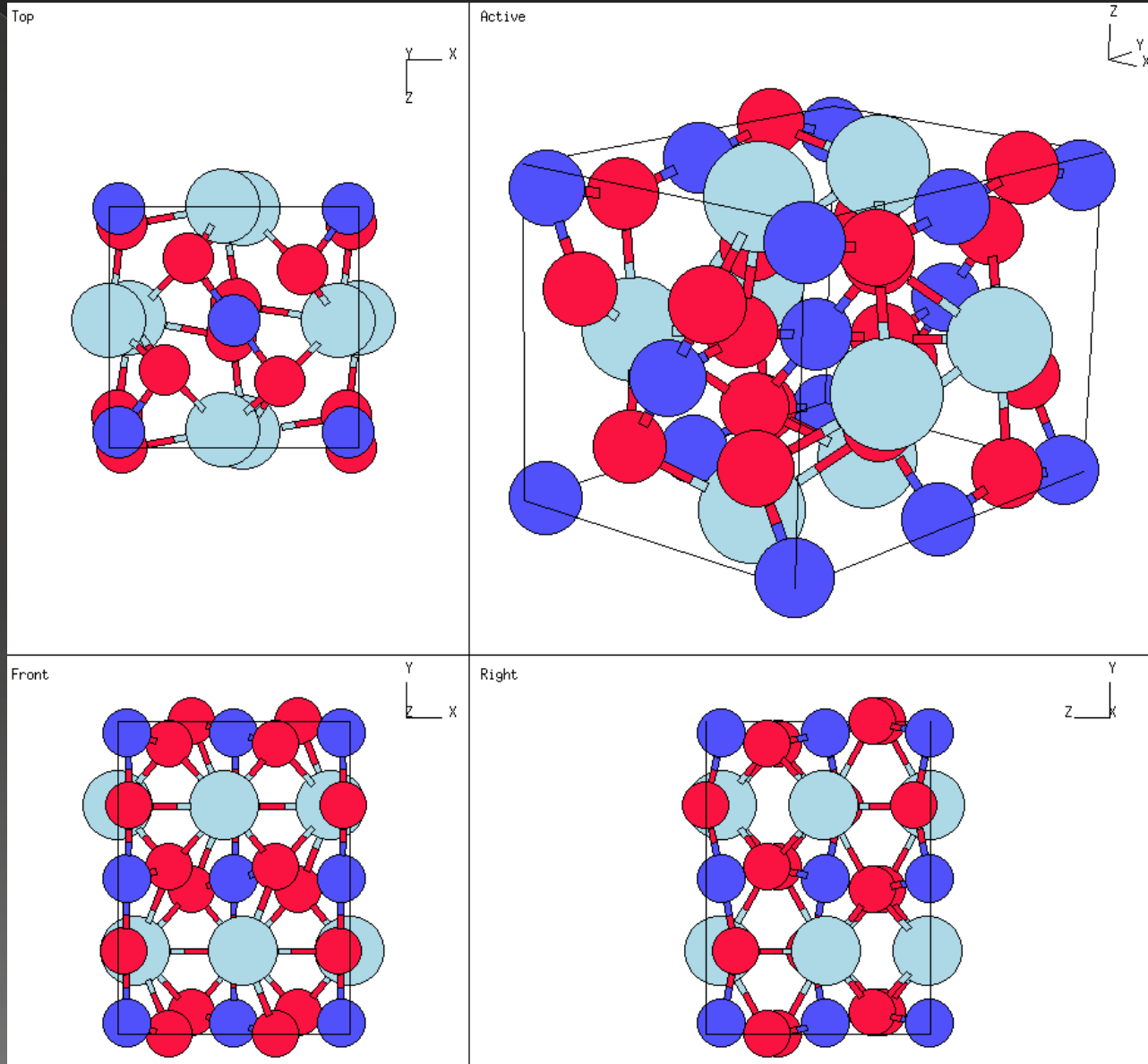
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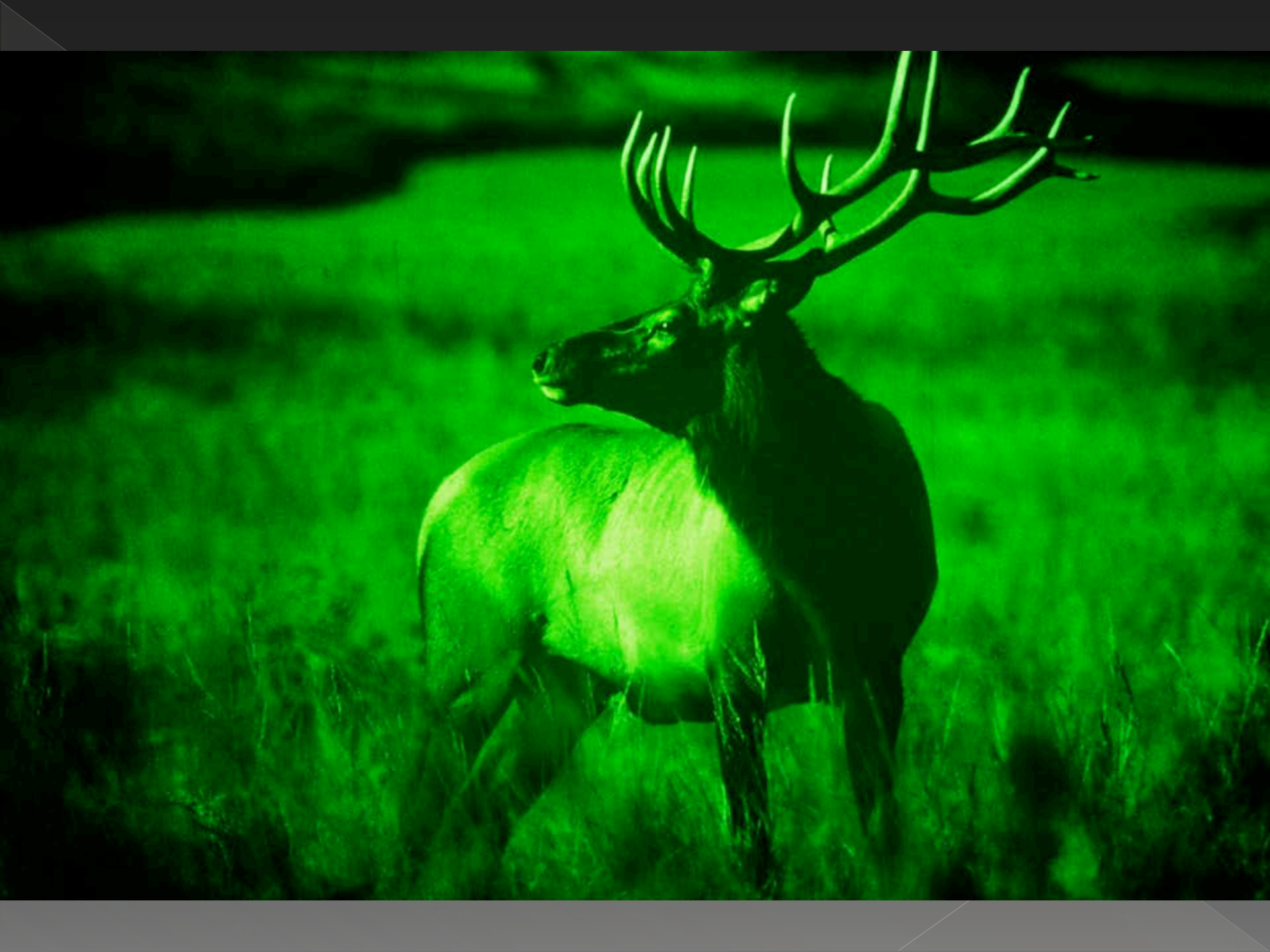


Right



PEROVSKITE (CaTiO_3)



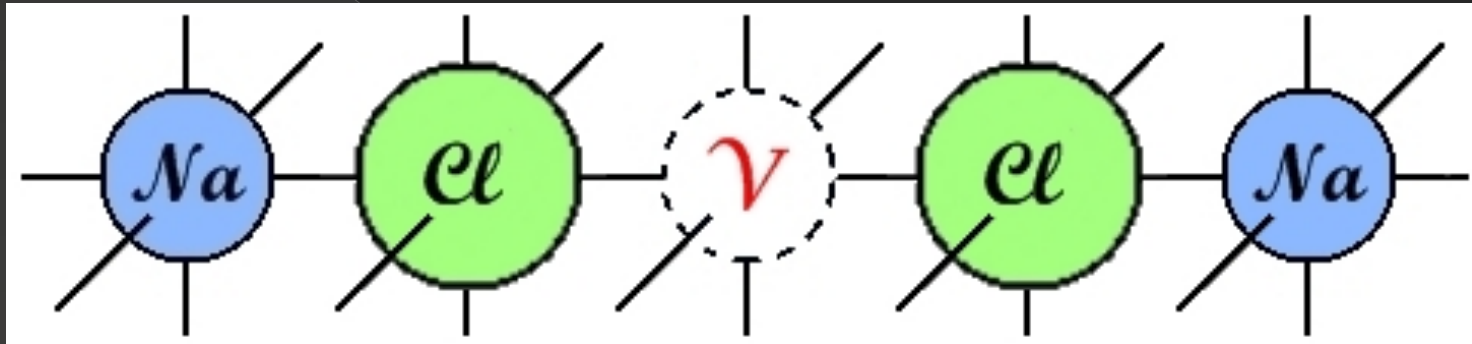


Kröger – Vink Notation

- Proposed in 1956 by F.A. Kröger and H.J. Vink in the journal *Solid State Physics* (F.A. Kröger, H.J. Vink, *Relations between the Concentrations of Imperfections in Crystalline Solids, Solid State Physics, Volume 3, 1956, 307-435*)
- Set of conventions used to describe lattice position and electric charge for point defects in crystalline structures
- The key concept is the crystal lattice to consist of POSITIONS and ATOMS

Vacancy

- There can be unoccupied positions :



these empty positions are called **VACANCIES**

- In the picture, there is a *Na* vacancy, which is symbolized by:



Vacancy & Charge

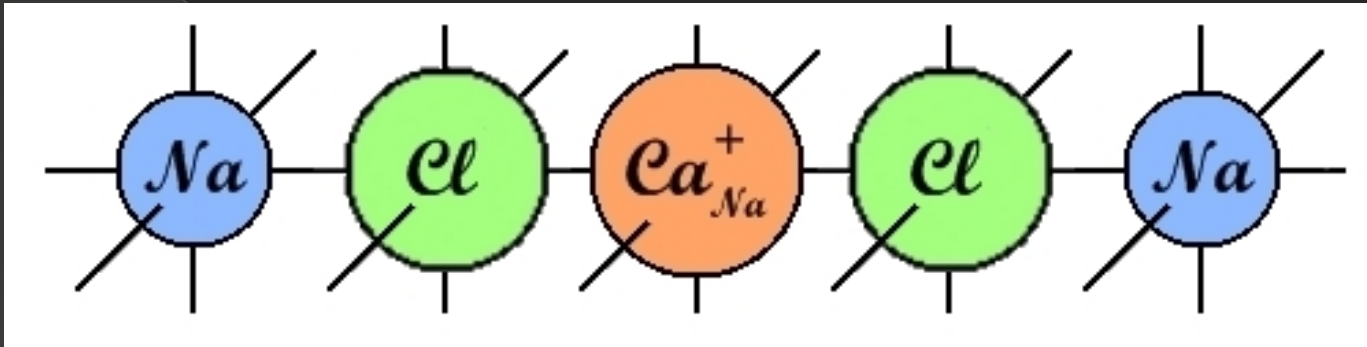
- However, like ions, also vacancies have charge:
e.g. proceeding with the previous example, the absence of a ion Na^+ leads to a lack of positive charge, meaning a negative charge concentration!
- Vacancies have always OPPOSITE CHARGE to the missing ion

Charge

- ⊙ | → negative charge e.g. $V_{Na}^{|}$
- ⊙ • → positive charge e.g. $V_O^{••}$ [Oxygen vacancy with 2 (+) charges]
- ⊙ × → neutrality e.g. Cl_{Cl}^{\times}
(neutrality may be unexpressed)

Substitutional defect

- An atom or a ion can be replaced by another:



- The *Ca* ion took the place of the *Na* ion, which is symbolized by:

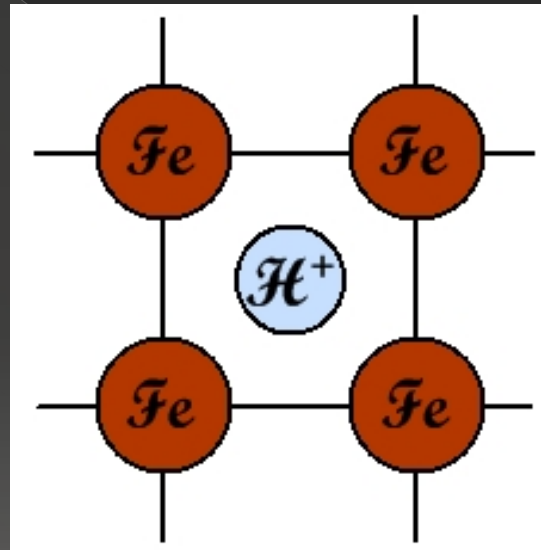


- As *Ca* ion has 2 (+) charges, while *Na* ion has only 1 (+) charge, there is a total 1 (+) charge, so:



Interstitial defect

- An atom or a ion can be present on any site that would be unoccupied in a perfect crystal, as is typical for H^+ ions in metallic lattice:



- Interstitial H^+ ion in Fe lattice is symbolized by:



Pure electric charge

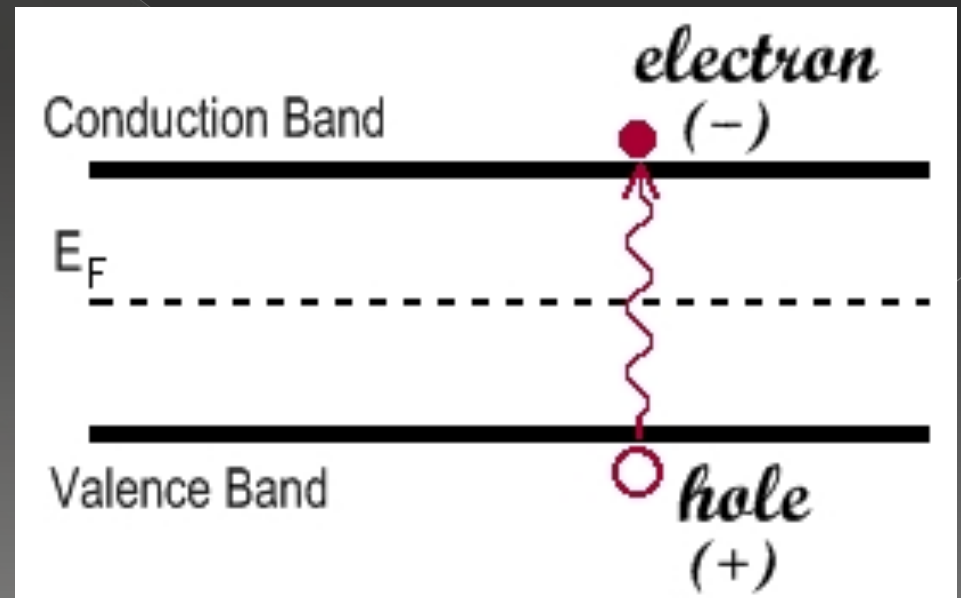
pure electric charges

electrons

"holes"

● electron: e^-

● hole: h^+



Quasi – Chemical Approach

to defect formation

- Apply Chemical Equilibrium concepts to solid dissolutions of a substance into another
- In order to be able to describe (hence with predictive purposes also) defects formation “reactions”

RULES for defect formation "reactions"

- 1) SITE BALANCE,
- 2) MASS BALANCE,
- 3) CHARGE BALANCE.

Given a generic compound $M_A X_B$:

- **SITE BALANCE**: at equilibrium the ratio of #M SITES (NOT actual atoms) to #X SITES must always be preserved
 - So, creating anionic sites must lead to the creation of cationic sites as well (and vice versa) IN THE RIGHT RATIO
- **MASS BALANCE**: defect formation reactions can't create nor destroy mass
- **CHARGE BALANCE** (Electro Neutrality Condition): preservation of crystal global neutrality
 - So, there can't be reactions which leave the crystal charged
 - So, the total sum of negative electric charges must be equal to total sum of positive charges

Defects



Perfect Crystal

- Crystal which has a completely ordered structure with atoms at rest and electrons distributed in the lowest possible energy states.
- But *REAL* crystals contain a variety of imperfections, or defects.
- In crystalline ceramics the structure and chemistry of the material will be determined by the kinetics of defect movement.

Defects

- What is special about ceramic defects is that they can be *charged*, while metals cannot.
- DEFECT HIERARCHY*: defects are often classified in terms of a dimensionality: 0D, 1D, 2D, or 3D.

"Dimension"	Defect
0	Point defects
1	Line defects
2	Surfaces Grain boundaries Phase boundaries
3	Volume defects

- NB: In spite of the classification, ALL these defects are three-dimensional!

Point defects

- Point defects are particularly important in ceramics because of the role they can play in determining the properties of a material.

e.g. the entire semiconductor industry is possible because of minute concentrations of point defects that are added to Si (dopants determine the whole material electrical properties: if it's n-type, p-type, or semi-insulating).

Point defects

● Types of point defects:

- **Misplaced atoms & Solute atoms** (*substitutional defects*: atoms or ions are replaced by others),
- **Vacancies** (empty positions),
- **Interstitials** (atoms or ions present on any site that would be unoccupied in a perfect crystal),
- **Electronic defects** (electrons and holes),
- **Associated centers** (two point defects which interact so that they can be considered as a single defect; if more atoms are involved, they would be called a *defect cluster* or a *defect complex*).

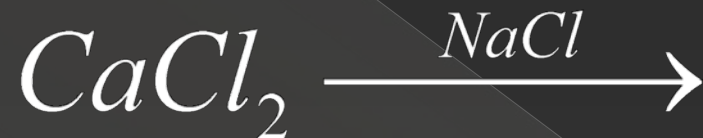
Solid Solutions

- If a material crystallizes in the presence of foreign atoms, their inclusion in the main crystalline structure could:
 - > Increase significantly system's energy \Rightarrow foreign atoms would be almost completely excluded from forming crystalline structure
 - > Decrease considerably system's energy \Rightarrow there would be the development of a new crystalline form
 - > In intermediate cases, foreign atoms would fit in a random way in the forming crystalline structure \Rightarrow SS
- SS are stable, of course, when the mixed crystal has a lower $\Delta G_{\text{formation}}$ than the other 2 alternatives.

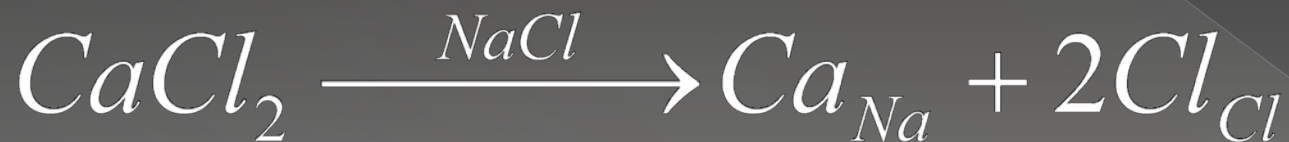
Let's try to apply Quasi – Chemical Approach rules to 2 real instances:

SS of calcium chloride ($CaCl_2$) in sodium chloride ($NaCl$), which we would assume as a perfect crystal:

- First of all, SS of $CaCl_2$ in $NaCl$ is indicated as follows:



- MASS BALANCE:**



- **CHARGE BALANCE:** being Ca^{++} the cation, it would probably substitute host Na^{+} cations, leading to an exceeding (+) charge \Rightarrow adding charges to previous equation:



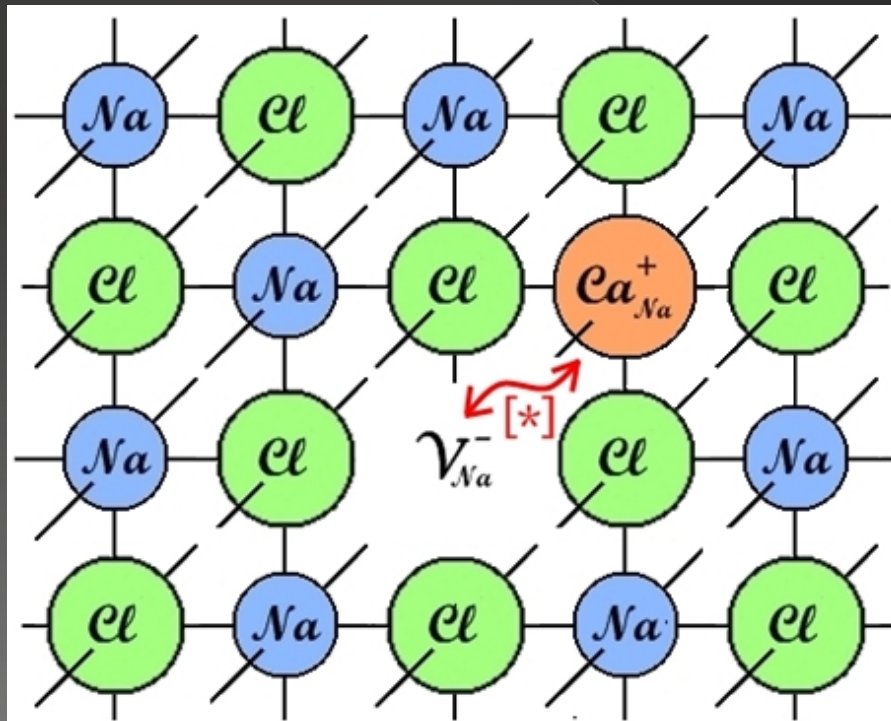
but this equation doesn't balance charges!! So...

- **SITE BALANCE:** in this example the right ratio anionic/cationic sites is 1:1: our equation doesn't balance lattice sites neither! So...



REMARKS:

- All balances are related to a perfect, neutral crystal.
- Having charge separation, we expect the new crystal to be a better conductor...
- The equation we wrote gives us a better knowledge of the system in an atomic scale:
e.g. we could represent it as:



$[*]$ close enough to
balance charges!

SS of titania (TiO_2) in magnesia (MgO), which we would still assume a perfect crystal

- Mg has a double valence, while Ti has 4 (+) charges...



Schottky Disorder

- Simultaneous anionic and cationic vacancies.
- Total stoichiometry of the solid isn't compromised by Schottky disorders, because the number of empty M and X sites is balanced as to preserve local electro neutrality.
- Opposite charged vacancies tend to associate (they carry an *effective* charge), so they'd never be too far-away from one another.
- Schottky disorder formation "reaction":



Schottky Disorder

- ⦿ This is a common defect in *alkali halides* at high T.
- ⦿ In oxides vacancies $\Delta G_{\text{formation}}$ is 2X-3X $\Delta G_{\text{formation}}$ (alkali halides), so at equilibrium the number of S. disorders is not relevant until very high T.

Frenkel Disorder

- Auto-interstitial defect: there is the same number of reticular vacancies and interstitial atoms, cause reticular atoms migrate in interstitial positions.



Frenkel Disorder

- ⦿ This is a common defect in:
 - > Crystals with fluorite structure, which has large interstitial sites.
 - > Crystals with high polarizable ions, which can in an easier way set up in interstitial sites.
- ⦿ The energy change for F. disorder formation depends strongly on reticular structure and ion characteristics.

Some more examples

SS of TiO_2 in MgO

- ◉ We wrote



for substitutional SS, but it could be also an interstitial SS:



- ◉ Which one is better?
 - Evaluate ΔG° and choose the favorite!
 - Usually it is $\Delta G_i \gg \Delta G_V \Rightarrow$ easier formation of vacancies than interstitials.

SS of TiO_2 in MgO

- This specific instance follows that general rule, too, as the passage of atoms to interstitial positions requires quite high energies:

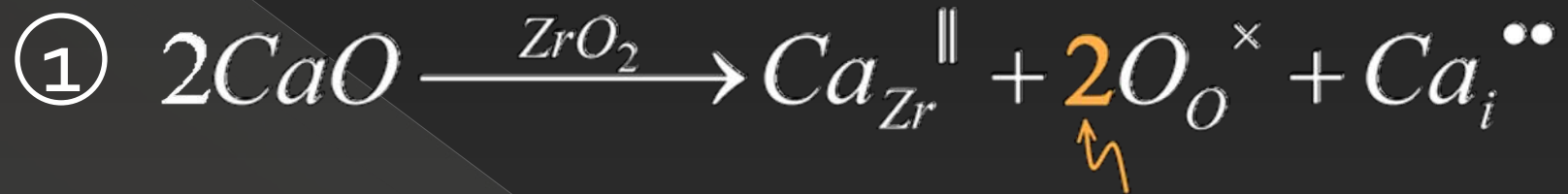
$$\Delta H_i \gg \Delta H_V$$

- \Rightarrow almost the entire part of defects will be substitutional:



Zirconia doped with calcia

- There are, again, 2 possibilities:



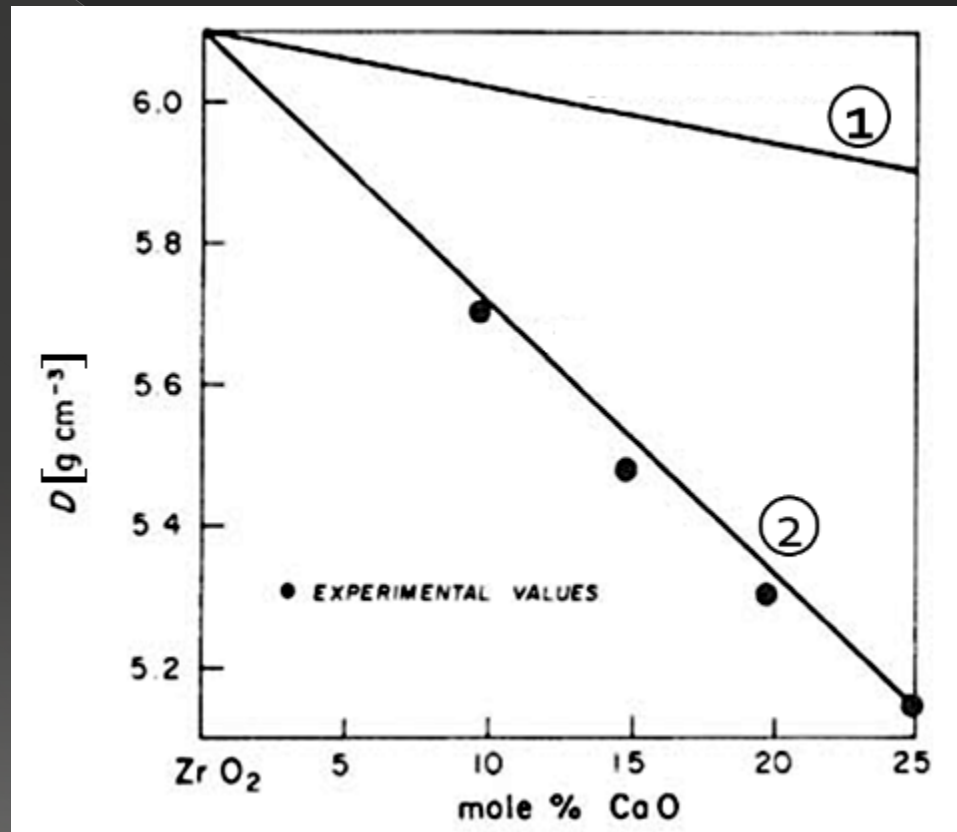
to maintain constant the ratio anionic/cationic sites
in zirconia's reticulum
(of course interstitial is not considered to this aim)



- Zirconia has a Fluorite structure \Rightarrow lots of empty space inside \Rightarrow interstitials are not automatically privileged...
- So??

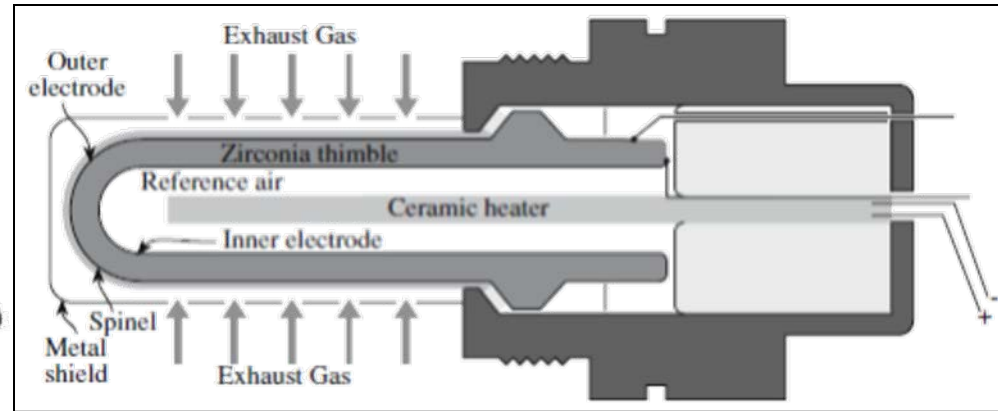
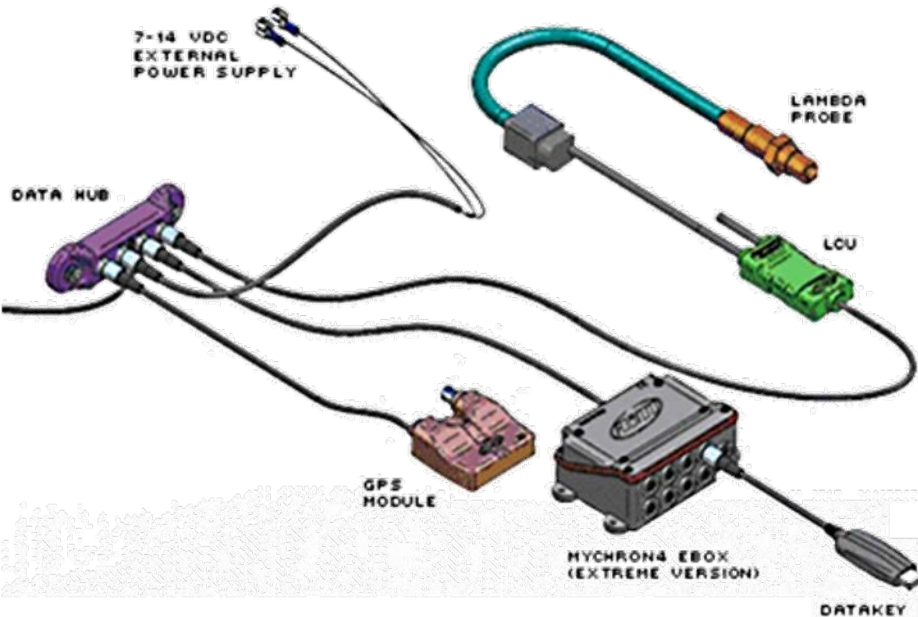
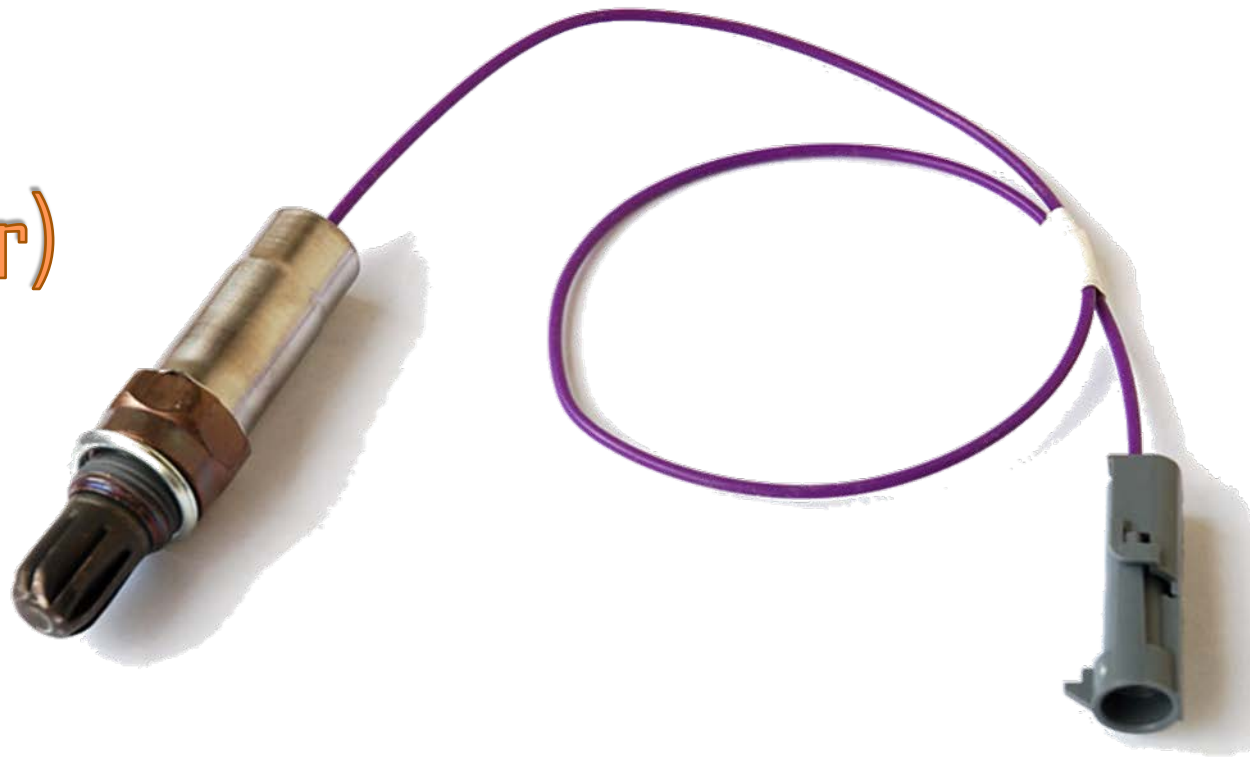
Zirconia doped with calcia

- Let's consider the profiles of density in function of mole % of CaO in ZrO_2 (at T_{amb}):



- Experimentally, reaction ② is the favourite.

Lambda sensor (or oxygen sensor)



Zirconia doped with yttria



- Applications of *pure* zirconia are restricted because it shows *polymorphism*:
 - > It is **monoclinic** at room temperature
 - > Changes to the denser **tetragonal** phase from circa 1000 °C.
- The phase change $t\text{-ZrO}_2 \rightleftharpoons m\text{-ZrO}_2$ shows a large change in volume ($\Delta V=5\%$) which causes extensive cracking.
- The addition of some oxides (like CaO, Y_2O_3) results in (meta)stabilizing the t-phase (or c-phase) at room temperature.



Yttria-stabilized Zirconia



Cubic zirconia (or CZ) : hard, optically flawless and usually colorless (but may be made in a variety of different colors). Single crystals of the cubic phase of zirconia are commonly used as diamond simulant in jewellery.

Magnesia doped with lithium fluoride



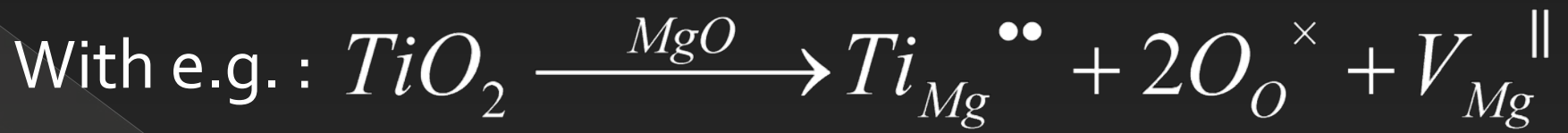
Magnesia doped with alumina



Quasi – Chemical Approach

Constant of Reaction

- ⦿ There's a need of a more immediate way to estimate defect concentration in crystals.
- ⦿ Applying:
 - > Kröger – Vink notation
 - > Quasi – Chemical approachto equations that represent defect formation's processes
- ⦿ A "*constant of reaction*" for those equation can be defined.



Defining: $n_Y = \# \text{ sites for species } Y$

$[M_X] = \text{fraction of } X \text{ species' reticular sites which have been occupied by } M \text{ atoms}$

$$[Ti_{Mg}^{\bullet\bullet}] = \frac{\# Ti^{4+} / cm^3}{\# Mg^{2+} / cm^3} = \frac{n_{Ti_{Mg}^{\bullet\bullet}}}{n_{Mg}}$$

\Rightarrow

$$[V_{Mg}^{\parallel}] = \frac{\# V_{Mg}^{\parallel} / cm^3}{\# Mg / cm^3} = \frac{n_{V_{Mg}^{\parallel}}}{n_{Mg}}$$

$$[O_O^{\times}] = \frac{\# O / cm^3}{\# O / cm^3} = 1$$

So:

$$K_r = \frac{[Ti_{Mg}^{\bullet\bullet}][V_{Mg}^{\parallel}][O_O^{\times}]^2}{a_{TiO_2}}$$

(where activity of solute specie is at the denominator)

And, going on with the “Quasi – Chemical” approach:

$$K_r = e^{-\frac{\Delta G^\circ}{RT}}$$

Where ΔG° is energy change associated with the dissolution process of TiO_2 in MgO

\Rightarrow

$$\frac{[Ti_{Mg}^{\bullet\bullet}][V_{Mg}^{\parallel}][O_O^{\times}]^2}{a_{TiO_2}} = e^{-\frac{\Delta G^\circ}{RT}}$$

(1)

ENC (Electro Neutrality Condition):

$$\cancel{2en_{Ti_{Mg}^{\bullet\bullet}}} = \cancel{2en_{V_{Mg}^{\parallel}}}$$

$$\Rightarrow \frac{n_{Ti_{Mg}^{\bullet\bullet}}}{n_{Mg}} = \frac{n_{V_{Mg}^{\parallel}}}{n_{Mg}} \Rightarrow [Ti_{Mg}^{\bullet\bullet}] = [V_{Mg}^{\parallel}]$$

Finally, the (1) becomes:

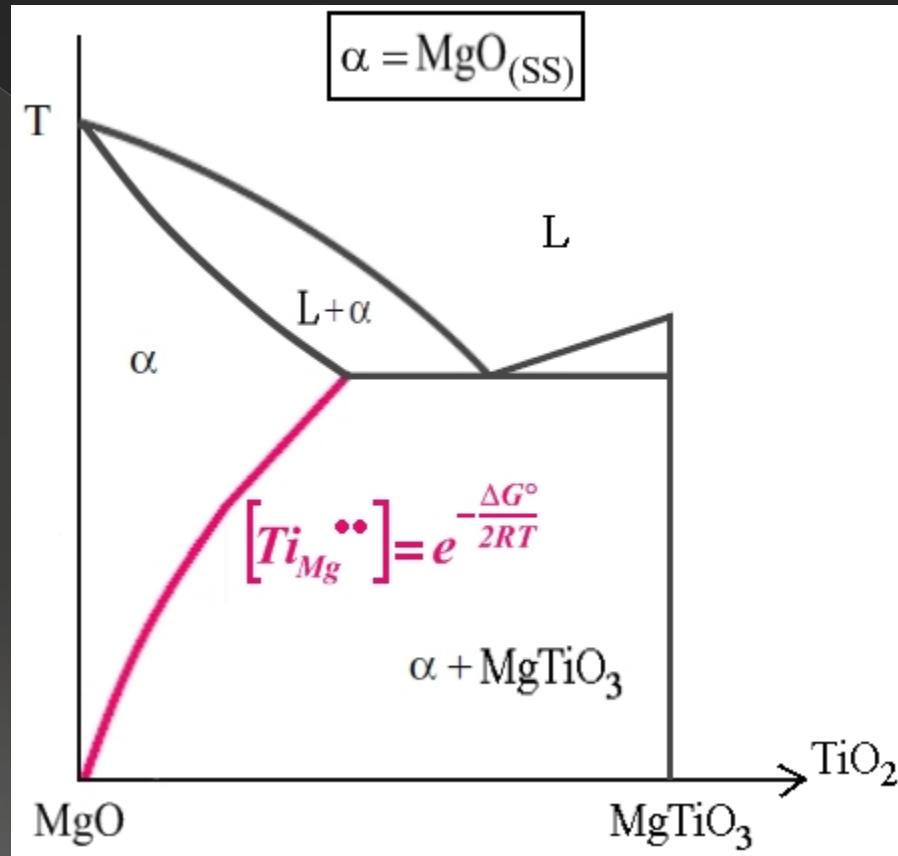
$$[Ti_{Mg}^{\bullet\bullet}] = (a_{TiO_2})^{1/2} e^{-\frac{\Delta G^\circ}{2RT}} \quad (2)$$

which permit to ESTIMATE DEFECTS CONCENTRATION

NOTE: $0 < [Ti_{Mg}^{\bullet\bullet}] < 1$ 

Phase Diagram

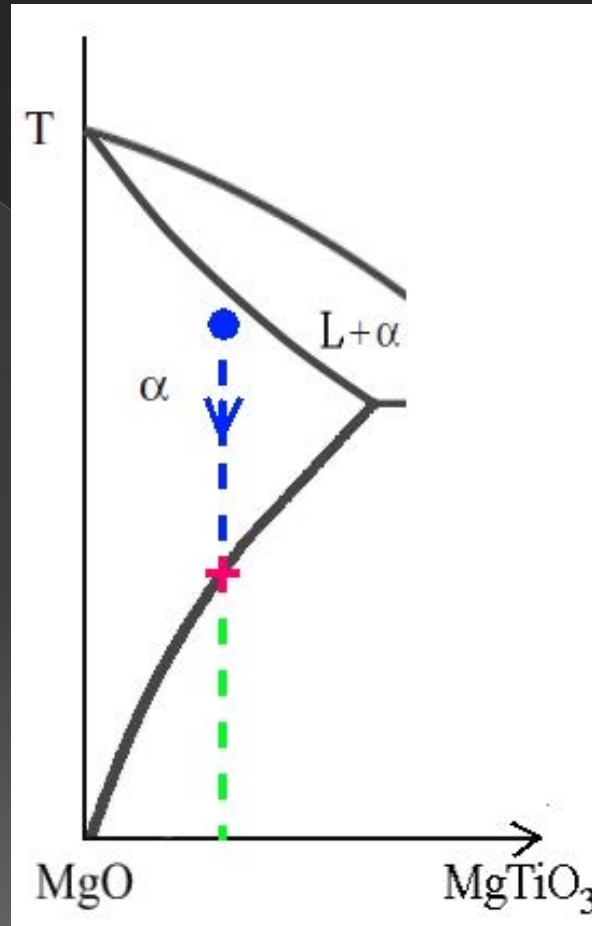
In the phase diagram:



From equation [2] we can also obtain an expression for the SOLVUS LINE (remembering that, for solids, at equilibrium activity is 1).

Phase Diagram

So, when you come down on a composition line:



activity changes till when you reach the *solvus line* → then
in the microstructure you'll have precipitation of TiO_2 .

Some examples

Schottky Disorder in magnesia



$$\Rightarrow [V_{Mg}^{\parallel}][V_O^{\bullet\bullet}] = K_r = e^{-\frac{\Delta H_s}{RT}}$$

With: $\Delta H_s = 7.5 \text{ eV/mol}$

Schottky Disorder in magnesia

$$n_O = n_{Mg} = n_{MgO} \Rightarrow [V_{Mg}^{\parallel}] = [V_O^{\bullet\bullet}] = e^{-\frac{\Delta H_s}{2RT}}$$

ENC: $2en_{V_O^{\bullet\bullet}} = 2en_{V_{Mg}^{\parallel}}$

- So, at $T = 2,000 \text{ K} \Rightarrow [V] \approx 10^{-9}$
- \Rightarrow in 1 *mol* there'll be $\approx 10^{+14}$ defects. $\left(n_V = [V] \cdot n_{MgO} \right)$
- NB: in a *real* crystal, there'll be, in any case, AT LEAST $10^{16} - 10^{17}$ defects/mol
- $\Rightarrow [V] \approx 10^{-6} - 10^{-7}$

Schottky Disorder in alumina



$$[V_O^{\bullet\bullet}]^3 [V_{Al}^{\text{III}}]^2 = e^{-\frac{\Delta H_S}{RT}}$$

With: $\Delta H_S = 25eV$

Schottky Disorder in alumina

$$ENC: 2en_{V_O^{\bullet\bullet}} = 3en_{V_{Al}^{\text{III}}}$$



$$2n_O[V_O^{\bullet\bullet}] = 3n_{Al}[V_{Al}^{\text{III}}]$$

$$n_{Al} = 2n_{Al_2O_3}$$

$$n_O = 3n_{Al_2O_3}$$



$$2(3n_{Al_2O_3})[V_O^{\bullet\bullet}] = 3(2n_{Al_2O_3})[V_{Al}^{\text{III}}]$$

$$\Rightarrow [V_O^{\bullet\bullet}] = [V_{Al}^{\text{III}}]$$

$$\Rightarrow [V_O^{\bullet\bullet}] = [V_{Al}^{\text{III}}] = e^{-\frac{\Delta H_S}{5RT}}$$



Schottky Disorder in alumina

$$\Rightarrow [V_O^{\bullet\bullet}] = [V_{Al}^{\text{III}}] = e^{-\frac{\Delta H_S}{5RT}}$$

ΔH_S is sort of "medium E per defect"

So:

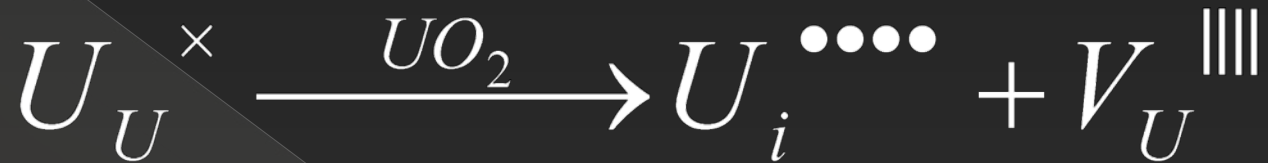
- > 1 Schottky disorder in alumina disarranges **5** points in crystal structure (3 V_O and 2 V_{Al})
- > 1 Schottky disorder in magnesia (previous example) disarranges **2** points in crystal structure (1 V_O and 1 V_{Mg})

Schottky disorder's energy of formation

SPECIE	ΔH_s [eV]	\Rightarrow E/defect [eV]
Al ₂ O ₃	25	~5
MgO	7.5	3.75
CaO	6.1	3.05
NaCl	2.30	1.65
KCl	2.26	1.1
LiF	2.34	1.17
LiCl	2.12	1.1
LiBr	1.80	0.9
LiI	1.30	0.7



Frenkel Disorder in urania



$$\frac{[U_i^{\bullet\bullet\bullet}][V_U^{\text{|||}}]}{[U_U^{\times}]} = e^{-\frac{\Delta H_F}{RT}}$$

- NB: thank to the low defect concentration, $[U_U]$ is SUBSTANTIALLY 1. 🏠

Frenkel Disorder in urania

$$ENC: 4en_{U_i^{\bullet\bullet\bullet}} = 4en_{V_U^{\text{III}}}$$

As urania has a fluorite structure it is: $n_i = \frac{1}{4}n_U$

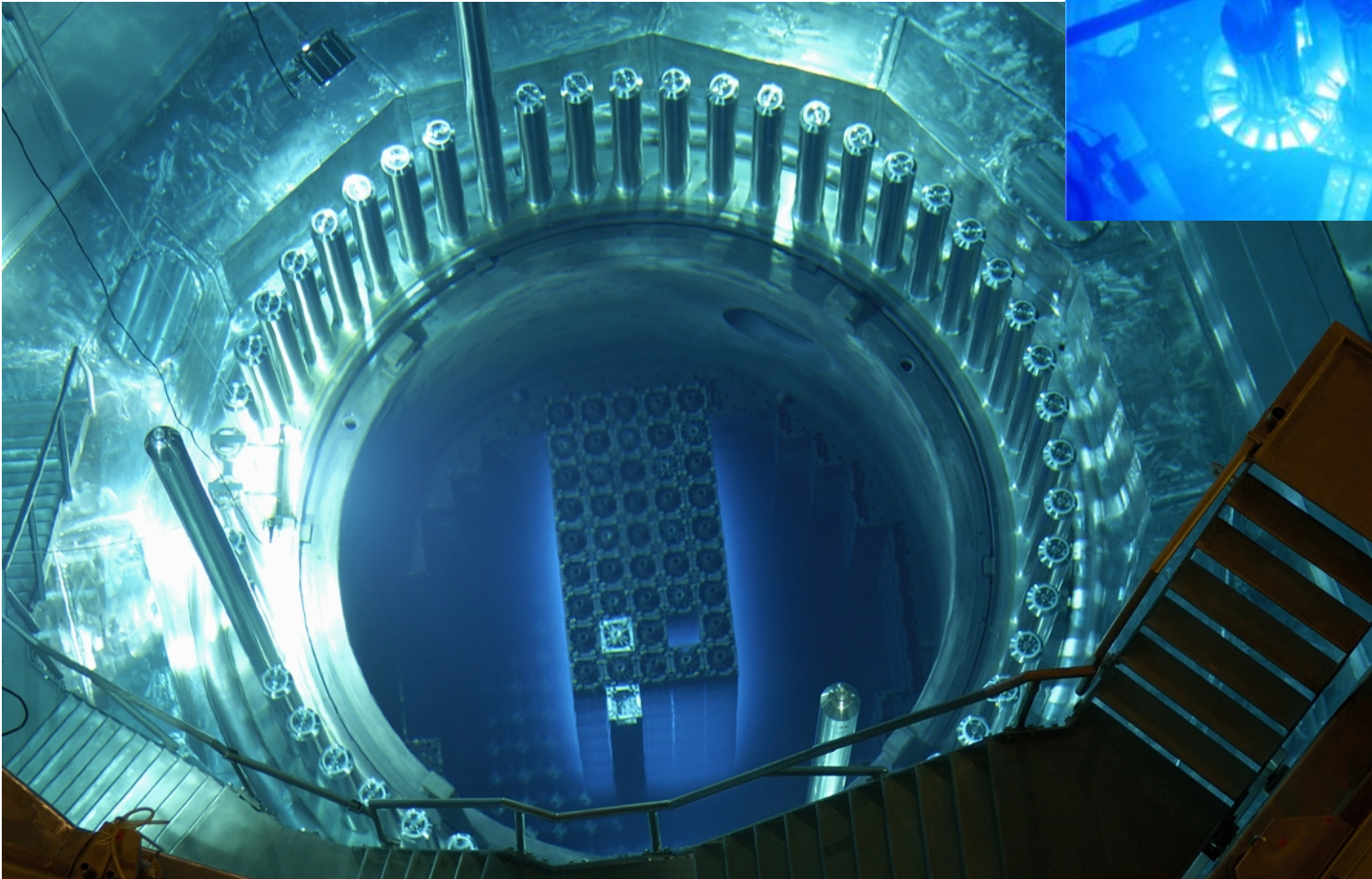
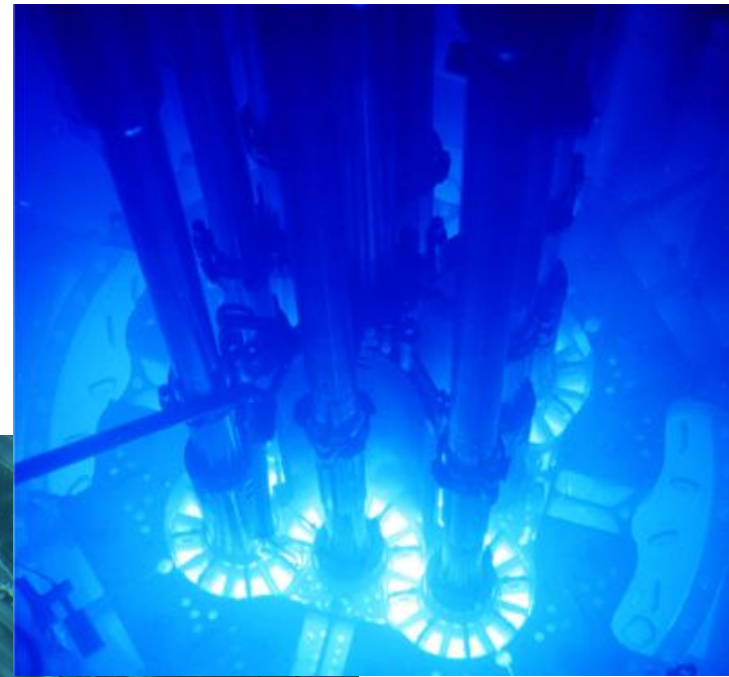
$$n_U = n_{UO_2}$$

$$\Rightarrow \frac{n_{U_i^{\bullet\bullet\bullet}}}{n_i} = 4 \frac{n_{U_i^{\bullet\bullet\bullet}}}{n_U} = 4 \frac{n_{V_U^{\text{III}}}}{n_U} \Rightarrow [U_i^{\bullet\bullet\bullet}] = 4[V_U^{\text{III}}]$$

$$\Rightarrow [U_i^{\bullet\bullet\bullet}]^2 = 4e^{-\frac{\Delta H_F}{RT}}$$

$$\Rightarrow [U_i^{\bullet\bullet\bullet}] = 4e^{-\frac{\Delta H_F}{2RT}}$$

Fuel rods for nuclear reactors

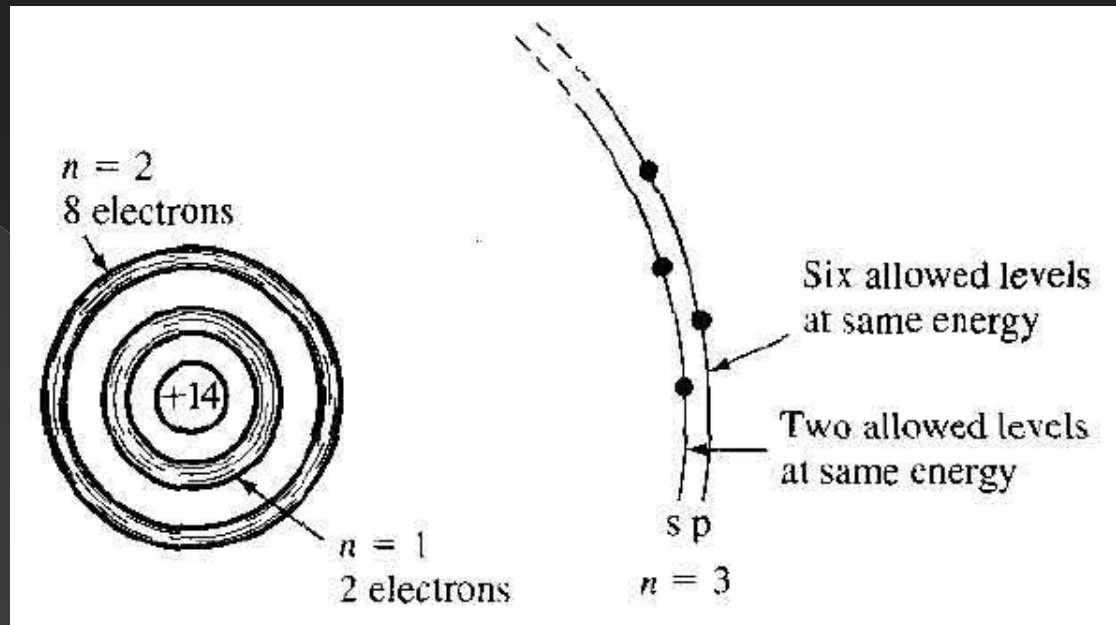


Frenkel disorder's energy of formation

STRUCTURE	MATERIAL – interstitial	ΔG [eV]
<u>Rocksalt</u> str.	MgO – Mg	13.5
	MgO – O	17.6
<u>Corundum</u>	Al ₂ O ₃ – Al	14
	Al ₂ O ₃ – O	16.5
<u>Fluorite</u> str.	UO ₂ – U	3.4
<u>Fluorite</u>	CaF ₂ – Ca	2.8
till 147 °C: <u>wurtzite</u> (over 147 °C: <u>CBC</u> and there is also a metastable form, with <u>sphalerite</u> str.)	AgI – Ag	0.75

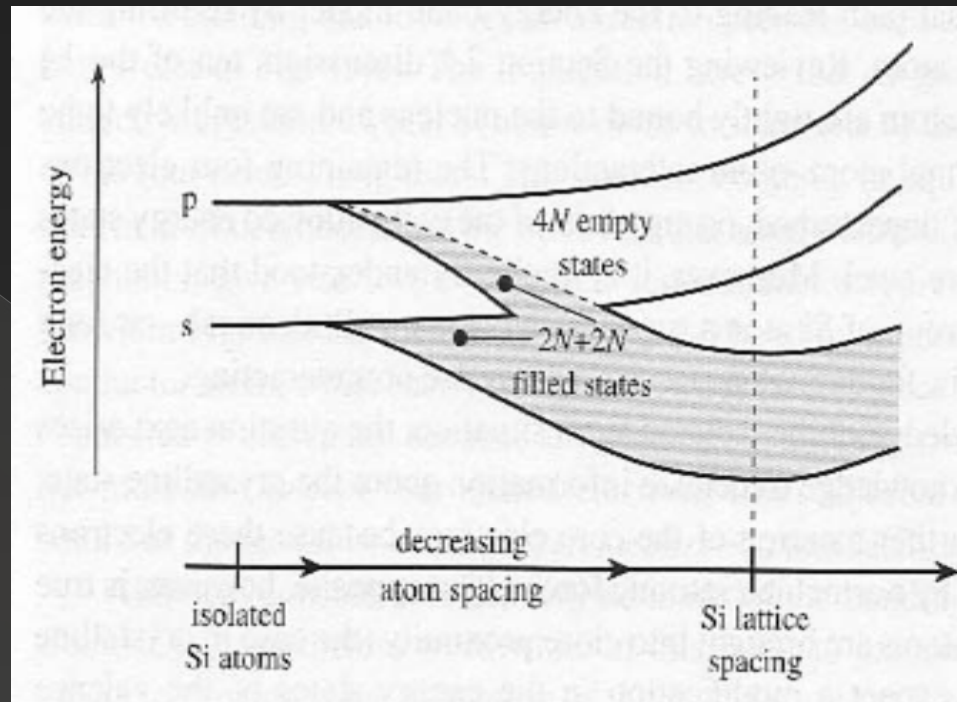
Oxygen has
also a bigger
steric effect

Concentrations of charge carriers (electrons and holes)



Schematic of an isolated Si atom

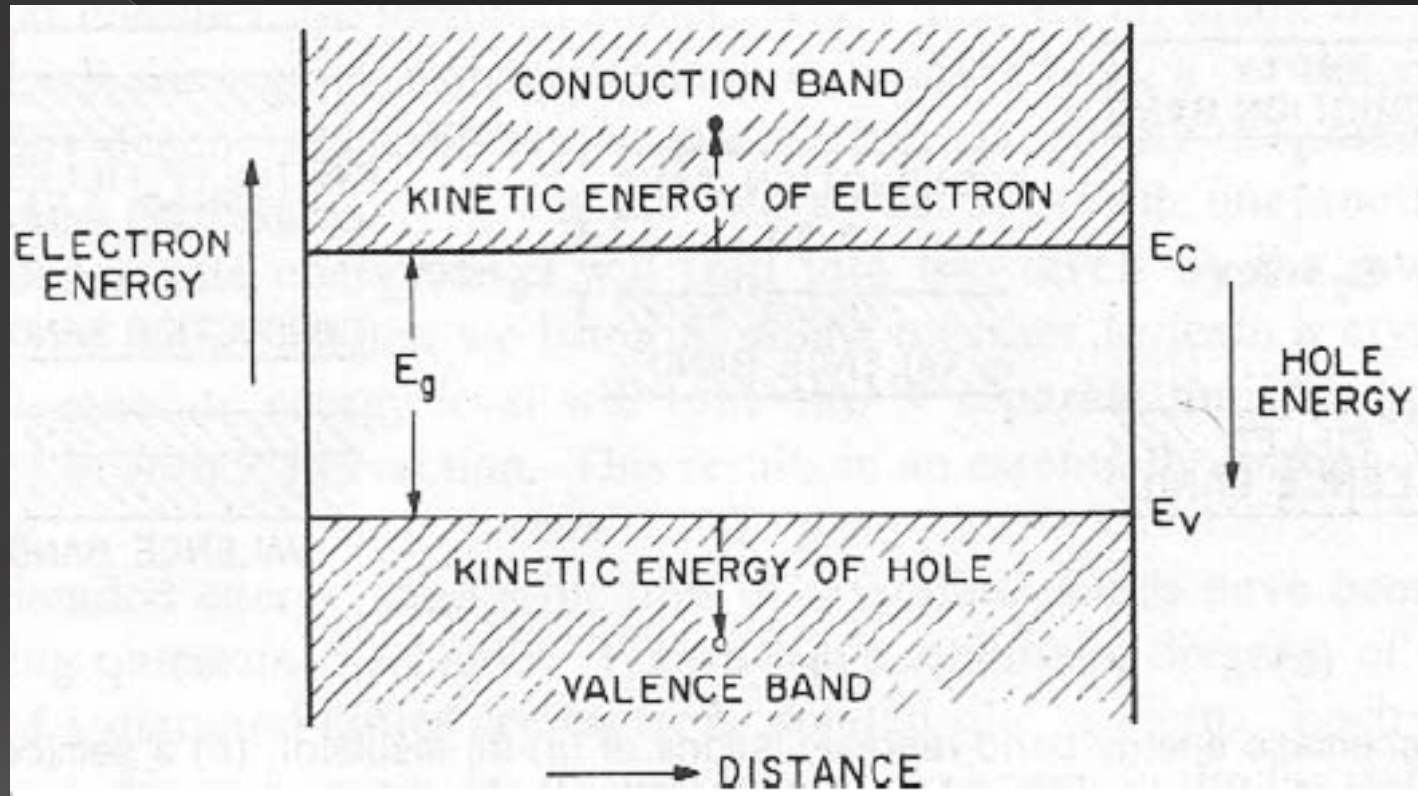
- Consider a regular periodic arrangement of atoms in which each atom contains more than one electron (eg Si).
- Suppose the atom in this imaginary crystal contains e^- up through the $n=3$ energy level.
- If the atoms are initially very far apart, the e^- in adjacent atoms will not interact and will occupy the discrete energy levels.



Splitting of the s and p states of Si into the allowed and forbidden energy bands

- If these atoms are brought closer together, somehow (quantum mechanics), their quantized energy levels split and turn into many states grouped in “energy bands” (see diagrams)
- Conduction only happens if electrons have empty “states” available at nearby energy

- Considering an intrinsic semiconductor we have:



- When an e^- springs from VB to CB, it leaves a hole in VB

- According to Quasi – Chemical approach it's possible to represent this process as:



$$\Rightarrow [e^{\cdot}][h^{\cdot}] = e^{-\frac{E_{GAP}}{RT}}$$

$$[e^{\cdot}] = \frac{n}{N_C} \quad [h^{\cdot}] = \frac{p}{N_V}$$

where:

$$n = \frac{\#e^{-}}{CC}$$

$$p = \frac{\#holes}{CC}$$

N_C = #available states (= electron E levels) in CB

N_V = #available states (= electron E levels) in VB

$$\Rightarrow \frac{n}{N_C} \frac{p}{N_V} = e^{-\frac{E_{GAP}}{RT}}$$

- ◉ We have that

$$N_C \cong N_V \cong 2.5 \cdot 10^{19} \frac{\#}{CC}$$

- ◉ This is a number little lower than the number of atoms in 1 CC
- ◉ So almost every atom contributes with one state

- If, as supposed, the S.C. is intrinsic, we can obtain the concentrations of charge carriers equation:

$$n = p = n_i$$

$$\Rightarrow np = n_i^2 = N_C N_V e^{-\frac{E_{GAP}}{RT}}$$

$$\Rightarrow n_i = \sqrt{N_C N_V} e^{-\frac{E_{GAP}}{2RT}}$$

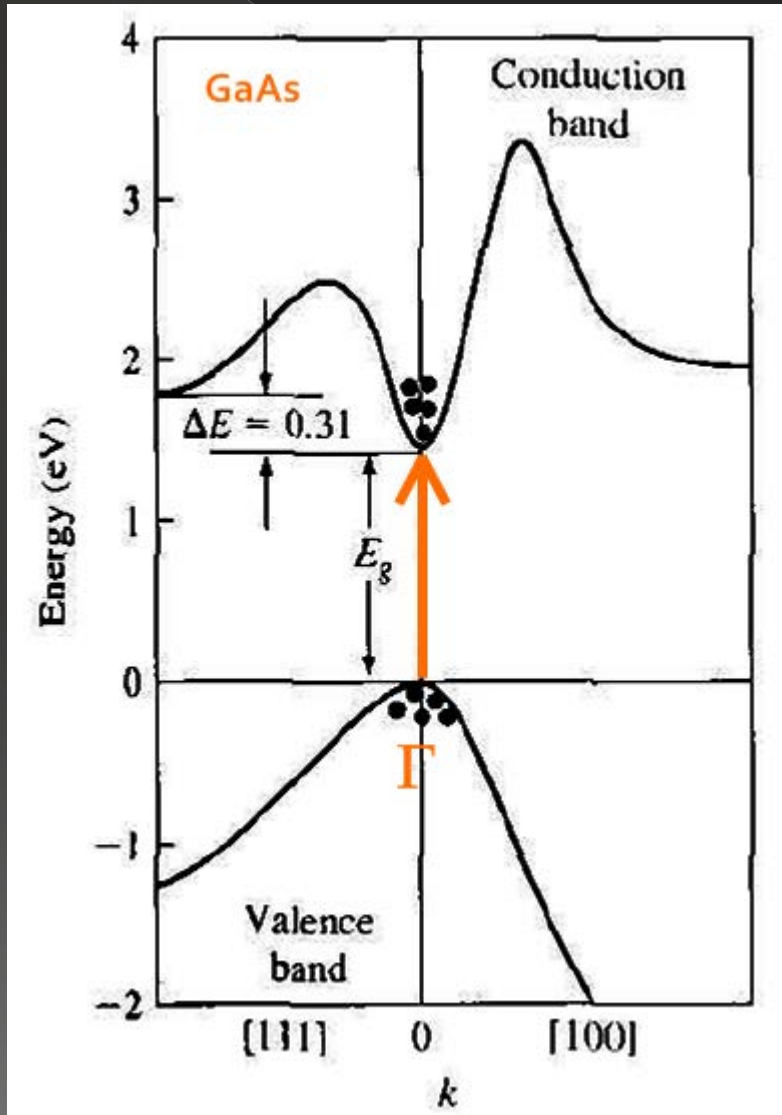
- Some E_{GAP} values for ceramics:

Ceramic	Energy gap [eV]
Al_2O_3	7
Si	1.1
Single crystal ZnO	3.2
Cd doped ZnO	~3.0
Mg doped ZnO	~4.0
Single crystal TiO_2	3.23

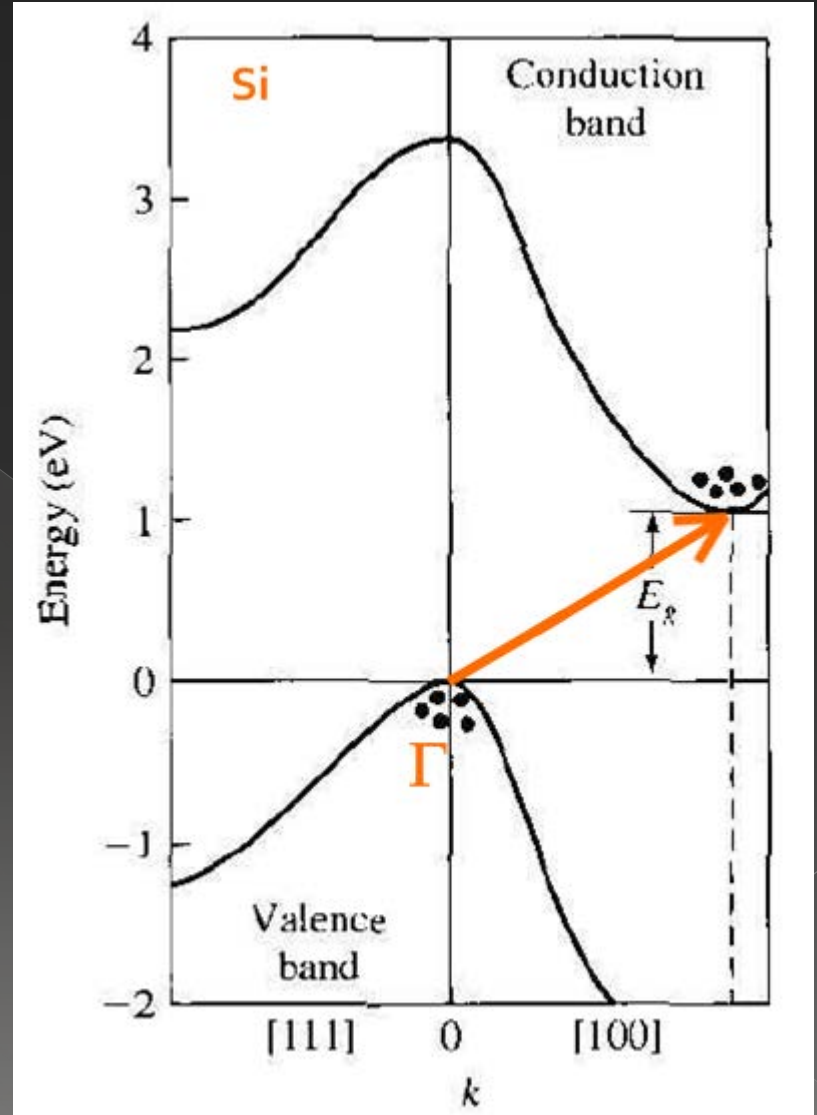
(Ceramics Science and Technology: Properties; Volume 2; Ralf Riedel, I-Wei Chen)

- Pay attention!!*** There are direct and indirect S.C.s, which means they may have respectively a direct or indirect transition...

Direct transition



Indirect transition



- Why did we evaluate ΔH (instead of ΔG)?
- Usually ΔG° is due mostly to system's free energy, as:

$$\Delta G = \Delta H - \Delta(TS)$$

Usually $\cong 1-2\%$ of ΔG
in solid dissolutions
(ppm)

$$\Delta H = \Delta U + \Delta(PV)$$

negligible in SOLIDS

$$\Rightarrow \Delta G \cong \Delta H \cong \Delta U$$



$$0 < [Ti_{Mg}^{\bullet\bullet}] < 1$$

qualitatively:

$$n_O = n_{Mg} = n_{MgO} = N_A \frac{\rho_{MgO}}{MW_{MgO}} =$$

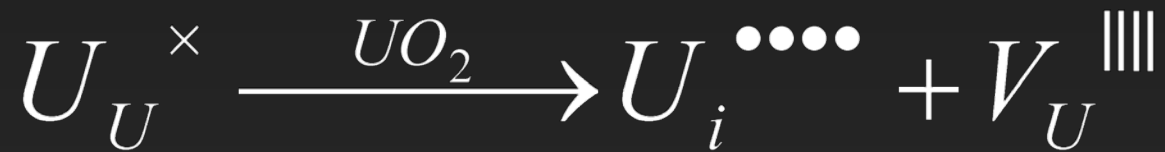
$$= \frac{6.023 \cdot 10^{23} \frac{\text{molecules}}{\text{mol}} \cdot 3.58 \frac{\text{g}}{\text{cm}^3}}{40.03 \frac{\text{g}}{\text{mol}}} \cong 4 \cdot 10^{22} \#/\text{cm}^3$$

If it is:

$$n_{Ti_{Mg}^{\bullet\bullet}} \cong 4 \cdot 10^{16} \#/\text{cm}^3$$

$$\Rightarrow [Ti_{Mg}^{\bullet\bullet}] \cong 10^{-6}$$





$[U_U]$ is SUBSTANTIALLY 1:

- Given a generic compound $M_A X_B$,
- With, e.g. 10^9 atoms of M:

$$[V_M] = 10^{-9} = \frac{1 \# V}{10^9 \# M}$$

$$[M_M] = \frac{\# M_{\text{left}} / CC}{\# M_{\text{in}} / CC} = \frac{\# M_{\text{left}}}{\# M_{\text{in}}} = \frac{\# M_{\text{in}} - \# V}{\# M_{\text{in}}} = \frac{10^9 - 1}{10^9} \longrightarrow 1$$



Non-stoichiometry in Kroger Vink Notation

- Cd_{1-x}O is non-stoichiometric (and this is due to the fact that more than one oxidation state is available for Cd)

- $\emptyset \rightarrow e' + h\cdot$ $[e'] [h\cdot] = K_e$ $K_e = e^{-E_g/RT}$

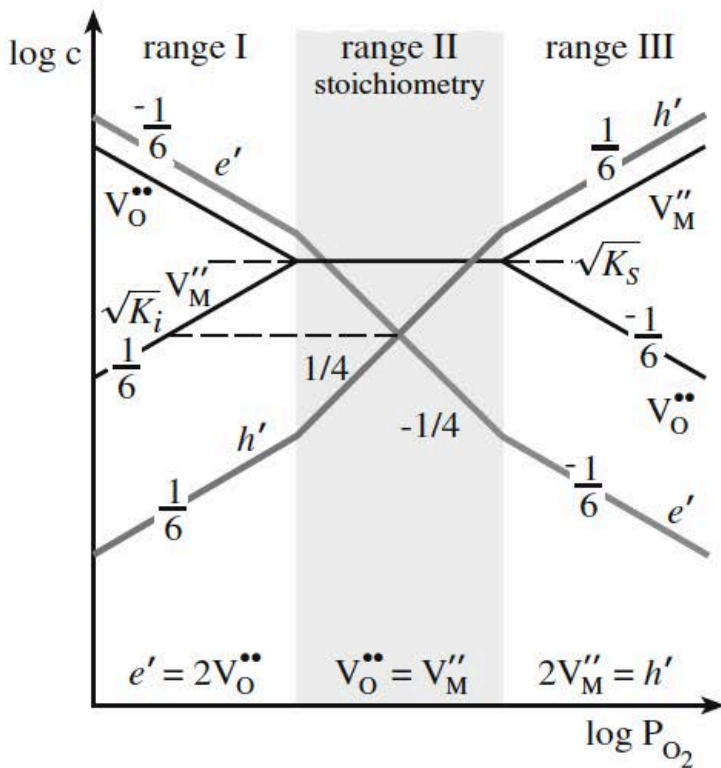
- $\emptyset \rightarrow V_{\text{O}}^{\cdot\cdot} + V_{\text{Cd}}^{//}$ $[V_{\text{O}}^{\cdot\cdot}] [V_{\text{Cd}}^{//}] = K_s$ $K_e = e^{-E_s/RT}$

- $\text{O}_2^x \rightarrow \frac{1}{2} \text{O}_{2(g)} + V_{\text{O}}^{\cdot\cdot} + 2e'$ $[V_{\text{O}}^{\cdot\cdot}] [e']^2 P_{\text{O}_2}^{1/2} = K_p$ $K_e = e^{-E_p/RT}$

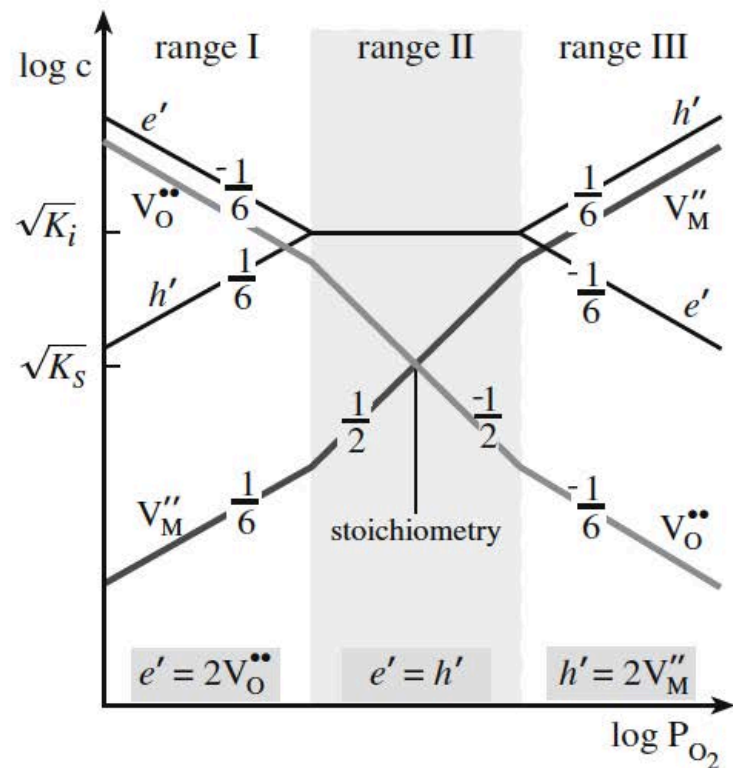
- $[e'] N_c + 2 [V_{\text{Cd}}^{//}] N_A \frac{\rho}{PM} = [h\cdot] N_v + 2 [V_{\text{O}}^{\cdot\cdot}] N_A \frac{\rho}{PM}$

- N_c density of states in the conduction band
- N_v density of states in the valency band
- N_A Avogadro's number
- ρ Density of CdO
- PM molecular weight of CdO

Kroeger-Vink diagram for metal oxide semiconductor MO

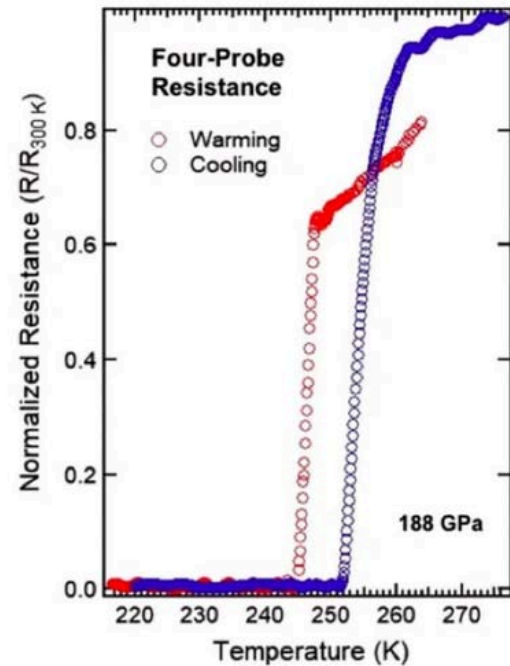


Schottki defects dominate



Electronic defects dominate

Famous case of non-stoichiometric compounds: ceramic superconductors



Properties of Ceramics

Melting temperatures

Al ₂ O ₃	2054 ± 6
BaO	2013
BeO	2780 ± 100
Bi ₂ O ₃	825
CaO	2927 ± 50
Cr ₂ O ₃	2330 ± 15
Eu ₂ O ₃	2175 ± 25
Fe ₂ O ₃	Decomposes at 1735 K to Fe ₃ O ₄ and oxygen
Fe ₃ O ₄	1597 ± 2
Li ₂ O	1570
Li ₂ ZrO ₃	1610
Ln ₂ O ₃	2325 ± 25
MgO	2852

Mullite	1850
Na ₂ O (α)	1132
Nb ₂ O ₅	1512 ± 30
Sc ₂ O ₃	2375 ± 25
SrO	2665 ± 20
Ta ₂ O ₅	1875 ± 25
ThO ₂	3275 ± 25
TiO ₂ (rutile)	1857 ± 20
UO ₂	2825 ± 25
V ₂ O ₅	2067 ± 20
Y ₂ O ₃	2403
ZnO	1975 ± 25
ZrO ₂	2677

B ₄ C	2470 ± 20
HfB ₂	2900
HfC	3900
HfN	3390
HfSi	2100
MoSi ₂	2030
NbC	3615
NbN	2204
SiC	2837
Si ₃ N ₄	At 2151 K partial pressure of N ₂ over Si ₃ N ₄ reaches 1 atm
TaB ₂	3150
TaC	3985
TaSi ₂	2400
ThC	2625

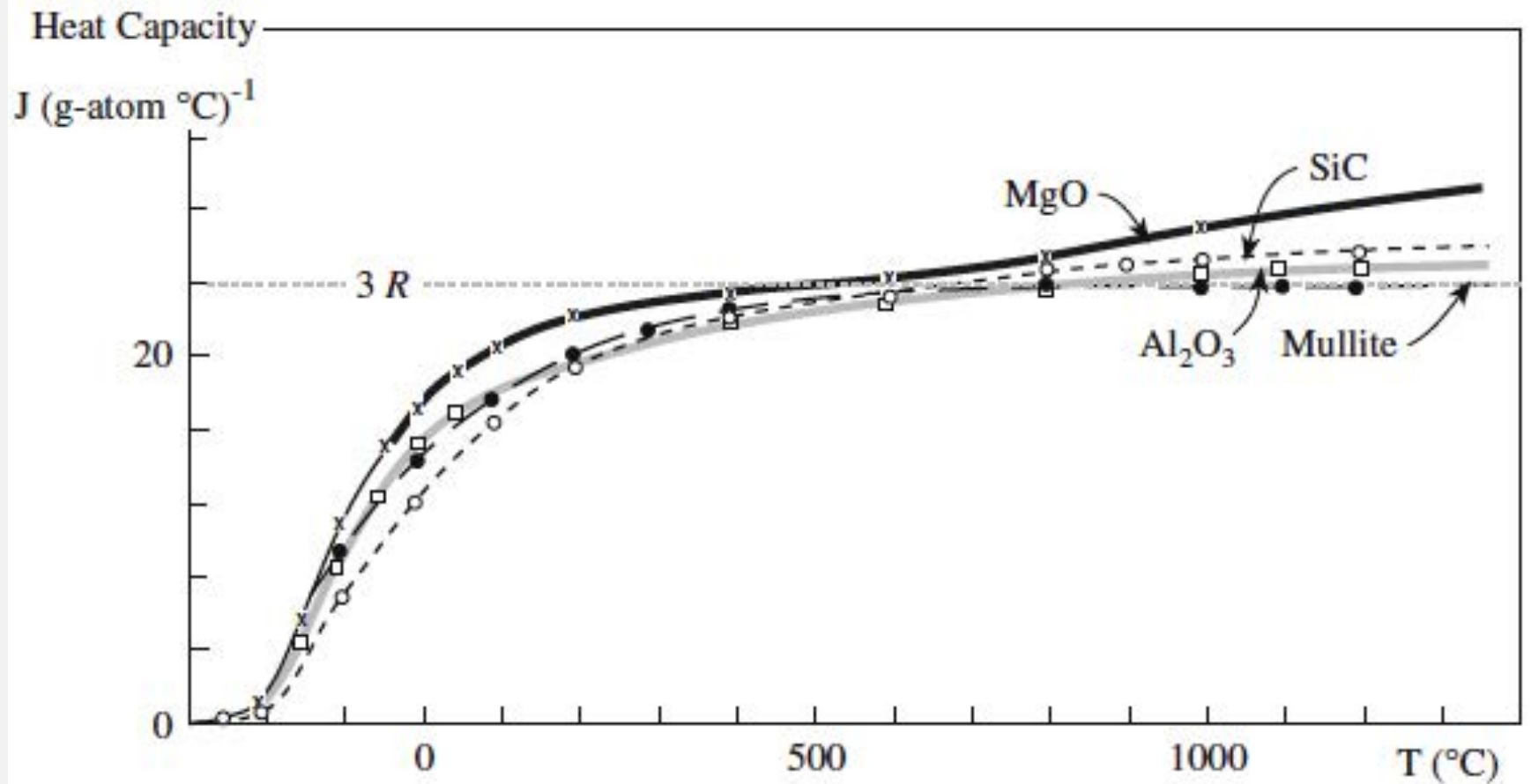
TABLE 34.3 Predominantly Covalent Ceramics with Very High Melting Temperatures

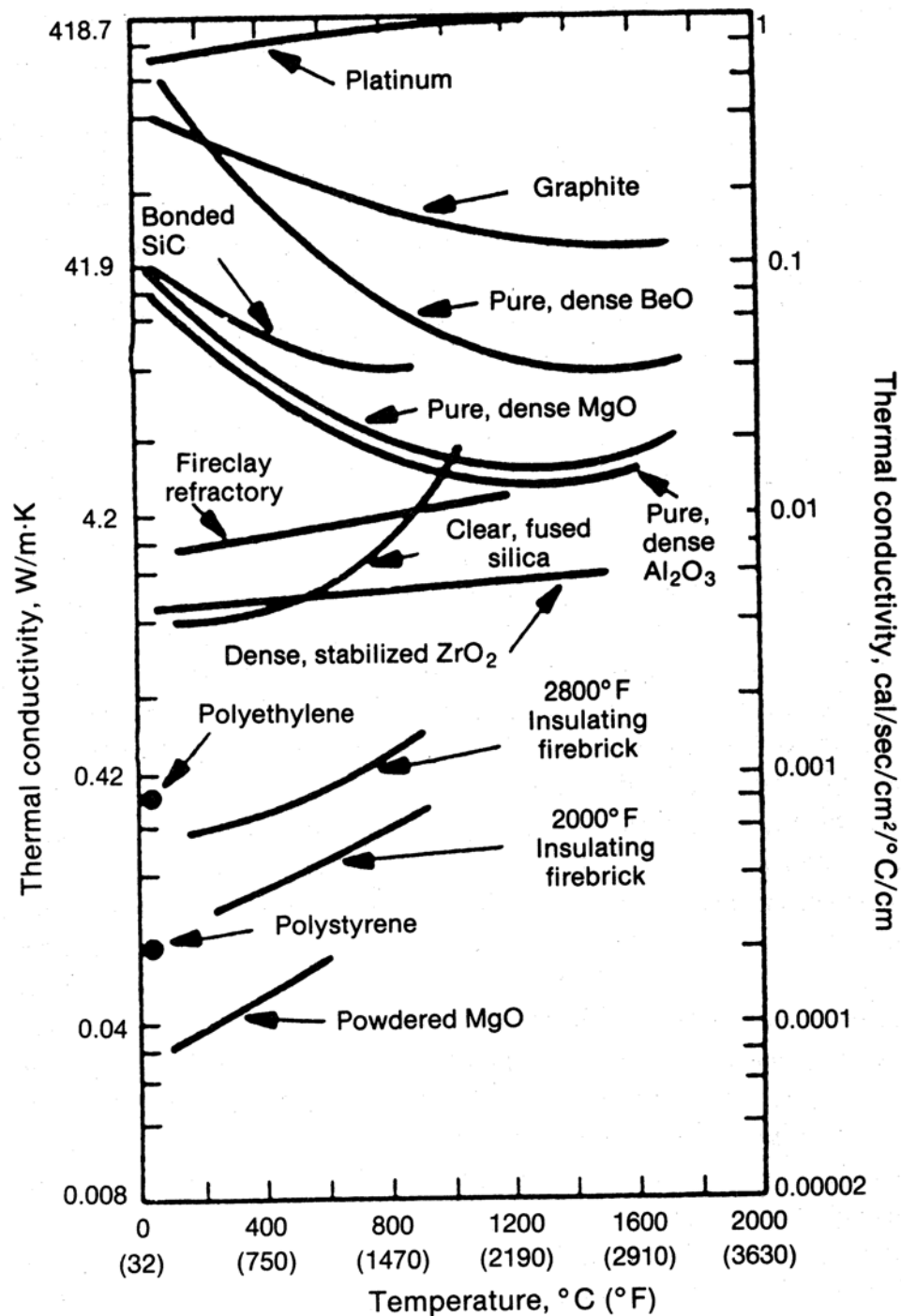
<i>Ceramic</i>	T_m (°C)	<i>Covalent character of bond (%)</i>
HfC	3890	70
TiC	3100	78
WC	2775	85
B ₄ C	2425	94
SiC	2300	88
C (diamond)	3727	100

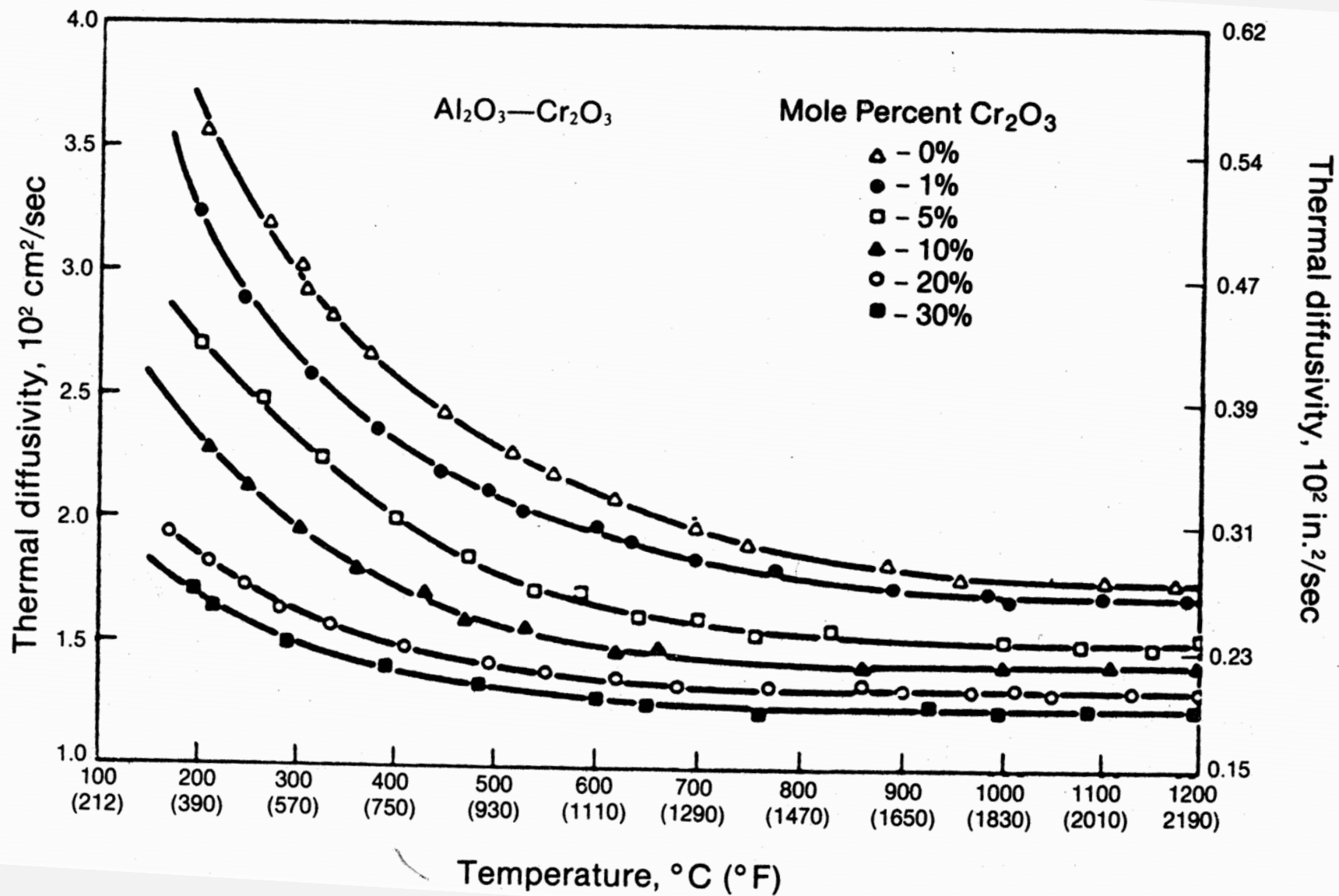
TABLE 34.4 Melting Temperatures of Alkaline Earth Metal Oxides

<i>Oxide</i>	T_m (°C)	<i>Covalent character (%)</i>	ϕ (nm ⁻¹) = Z/r
BeO	2780	37	57
MgO	2852	27	28
CaO	2927	21	20
SrO	2665	21	17
BaO	2017	18	15

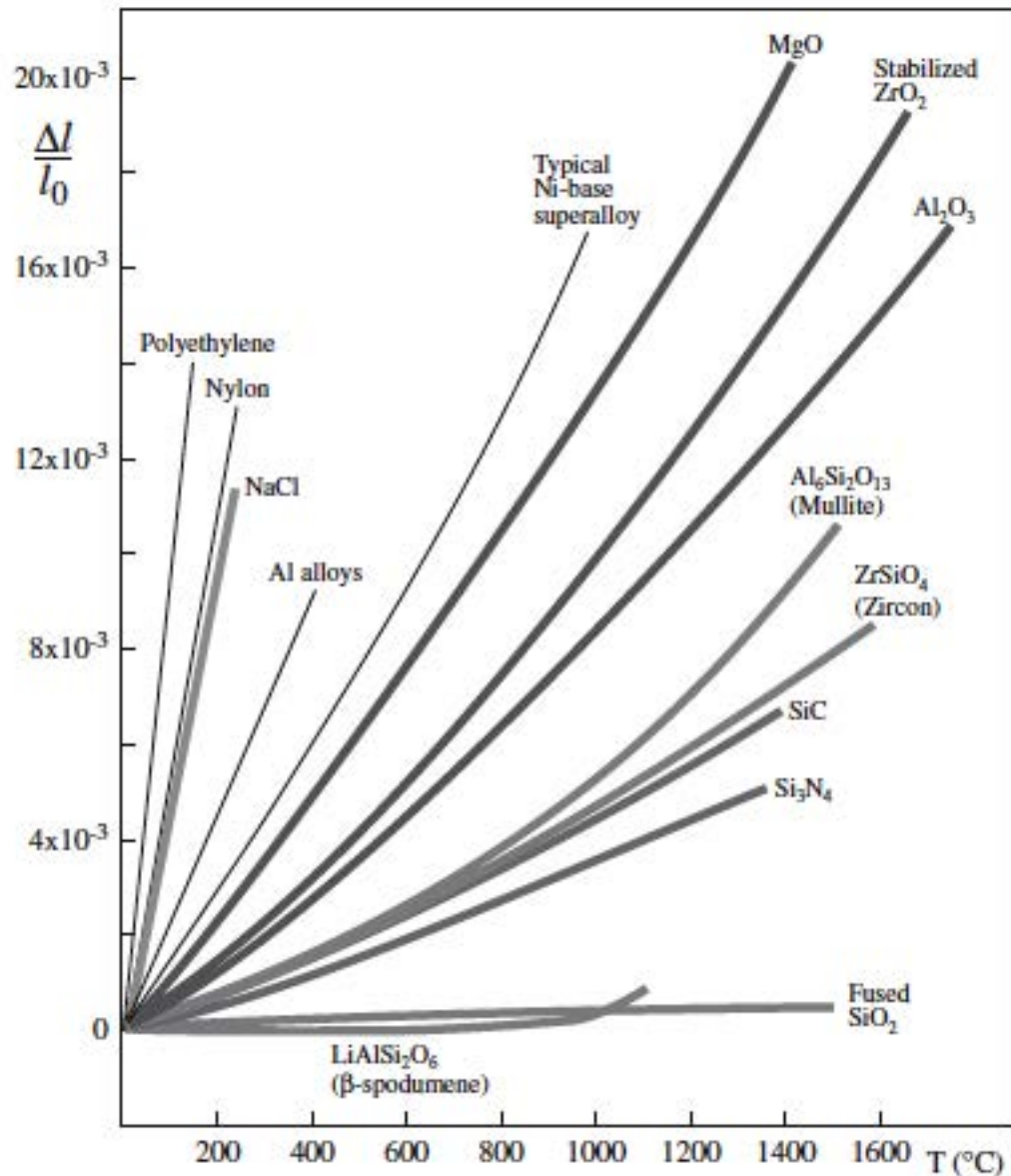
Heat capacity







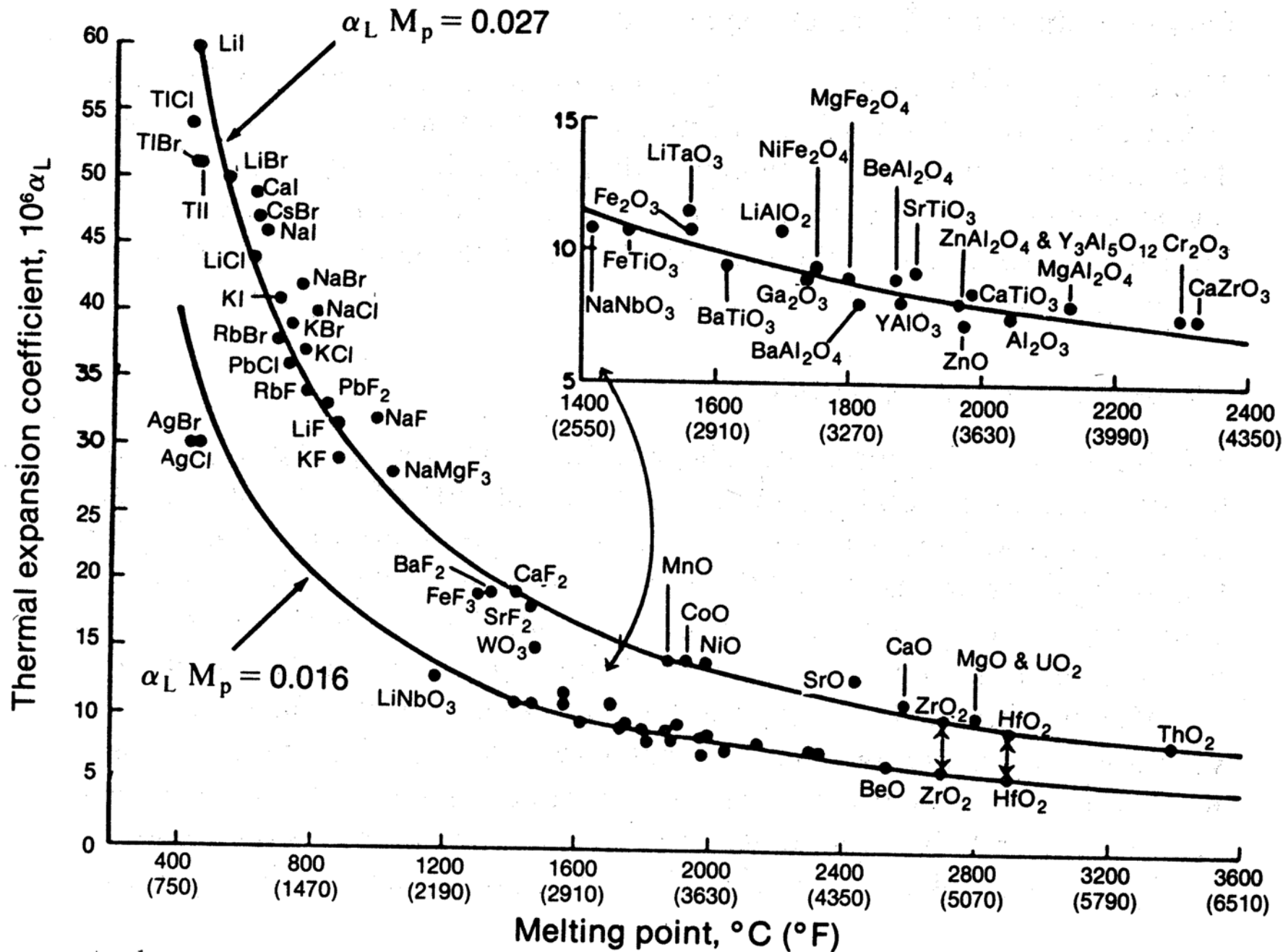
Thermal expansion



Thermal expansion

TABLE 34.9 Mean Thermal Expansion Coefficients of Various Ceramics

<i>Ceramic</i>	α (ppm/°C)	<i>Ceramic</i>	α (ppm/°C)
Binary oxides			
α -Al ₂ O ₃	7.2–8.8	ThO ₂	9.2
BaO	17.8	TiO ₂	8.5
BeO	8.5–9.0 (25–1000)	UO ₂	10.0
Bi ₂ O ₃ (α)	14.0 (RT–730°C)	WO ₂	9.3 (25–1000)
Bi ₂ O ₃ (δ)	24.0 (650–825°C)	Y ₂ O ₃	8.0 (<i>c</i> axis)
Dy ₂ O ₃	8.5	ZnO	4.0 (<i>a</i> axis)
Gd ₂ O ₃	10.5	ZrO ₂ (monoclinic)	7.0
HfO ₂	9.4–12.5	ZrO ₂ (tetragonal)	12.0
MgO	13.5		



Asby map Young modulus/density

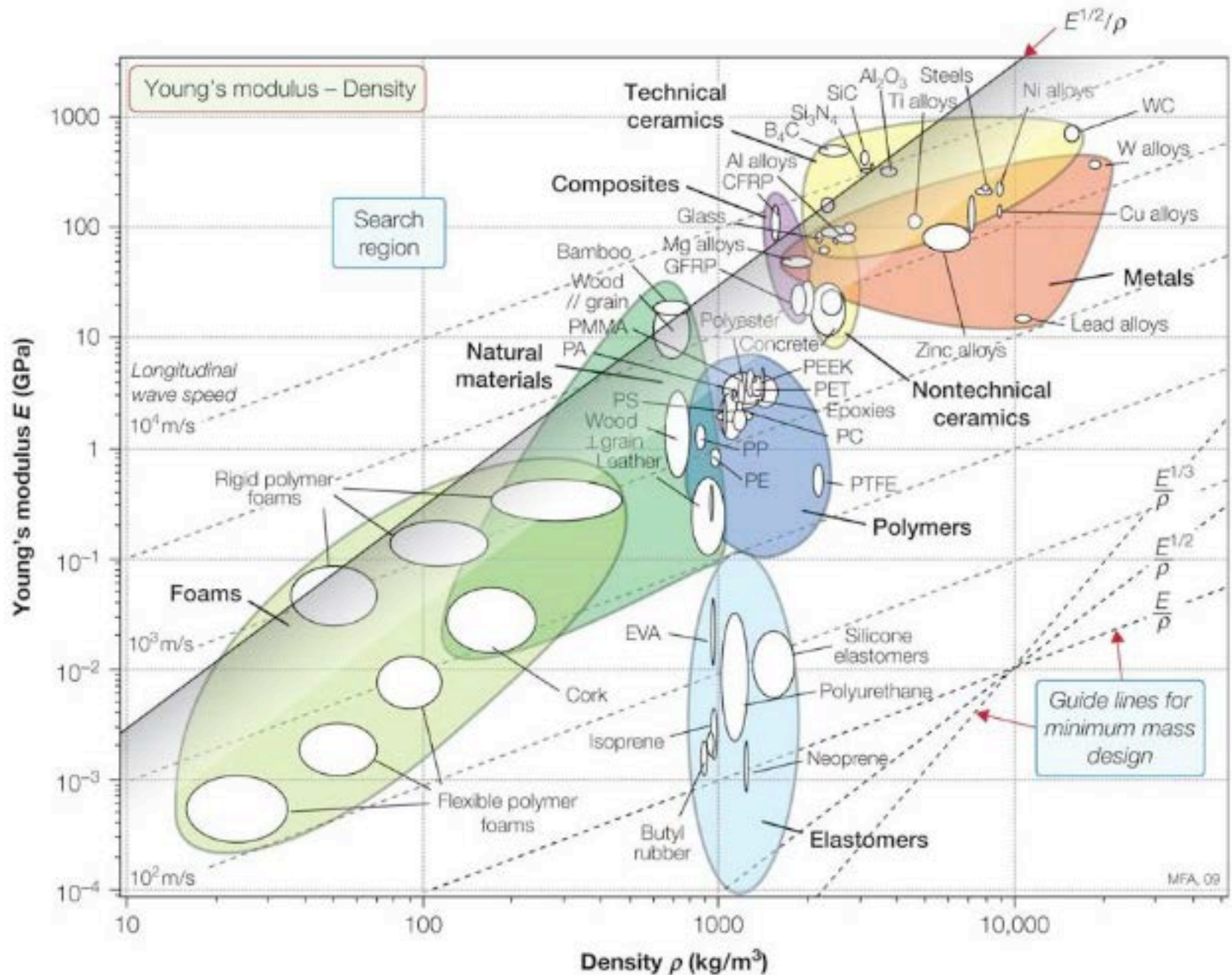


TABLE 16.2 Elastic Constants of Selected Polycrystalline Ceramics (20°C)

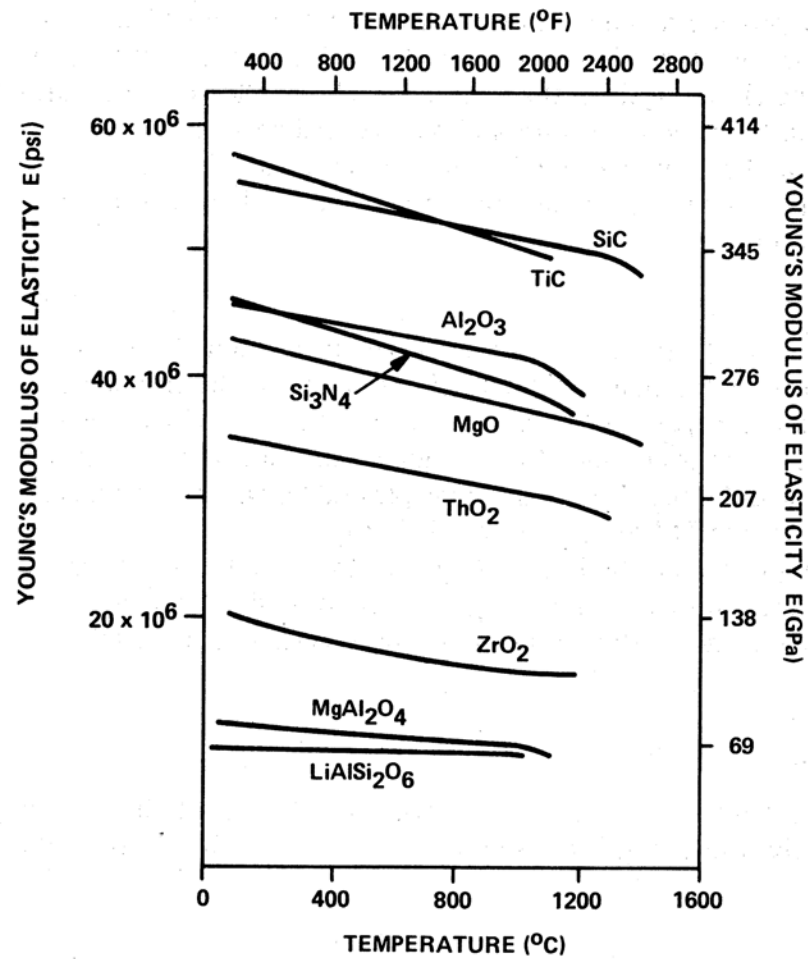
<i>Material</i>	<i>Crystal type</i>	μ (GPa)	B (GPa)	ν	E (GPa)
<i>Carbides</i>					
C	Cubic	468	416	0.092	1022
SiC	Cubic	170	210	0.181	402
TaC	Cubic	118	217	0.270	300
TiC	Cubic	182	242	0.199	437
ZrC	Cubic	170	223	0.196	407
<i>Oxides</i>					
Al ₂ O ₃	Trigonal	163	251	0.233	402
Al ₂ O ₃ ·MgO	Cubic	107	195	0.268	271
BaO·TiO ₂	Tetragonal	67	177	0.332	178
BeO	Tetragonal	165	224	0.204	397
CoO	Cubic	70	185	0.332	186
FeO·Fe ₂ O ₃	Cubic	91	162	0.263	230
Fe ₂ O ₃	Trigonal	93	98	0.140	212
MgO	Cubic	128	154	0.175	300
2MgO·SiO ₂	Orthorhombic	81	128	0.239	201
MnO	Cubic	66	154	0.313	173
SrO	Cubic	59	82	0.210	143
SrO·TiO ₂	Cubic	266	183	0.010	538
TiO ₂	Tetragonal	113	206	0.268	287
UO ₂	Cubic	87	212	0.319	230
ZnO	Hexagonal	45	143	0.358	122
ZrO ₂ –12Y ₂ O ₃	Cubic	89	204	0.310	233
SiO ₂	Trigonal	44	38	0.082	95

Relations among elastic constants

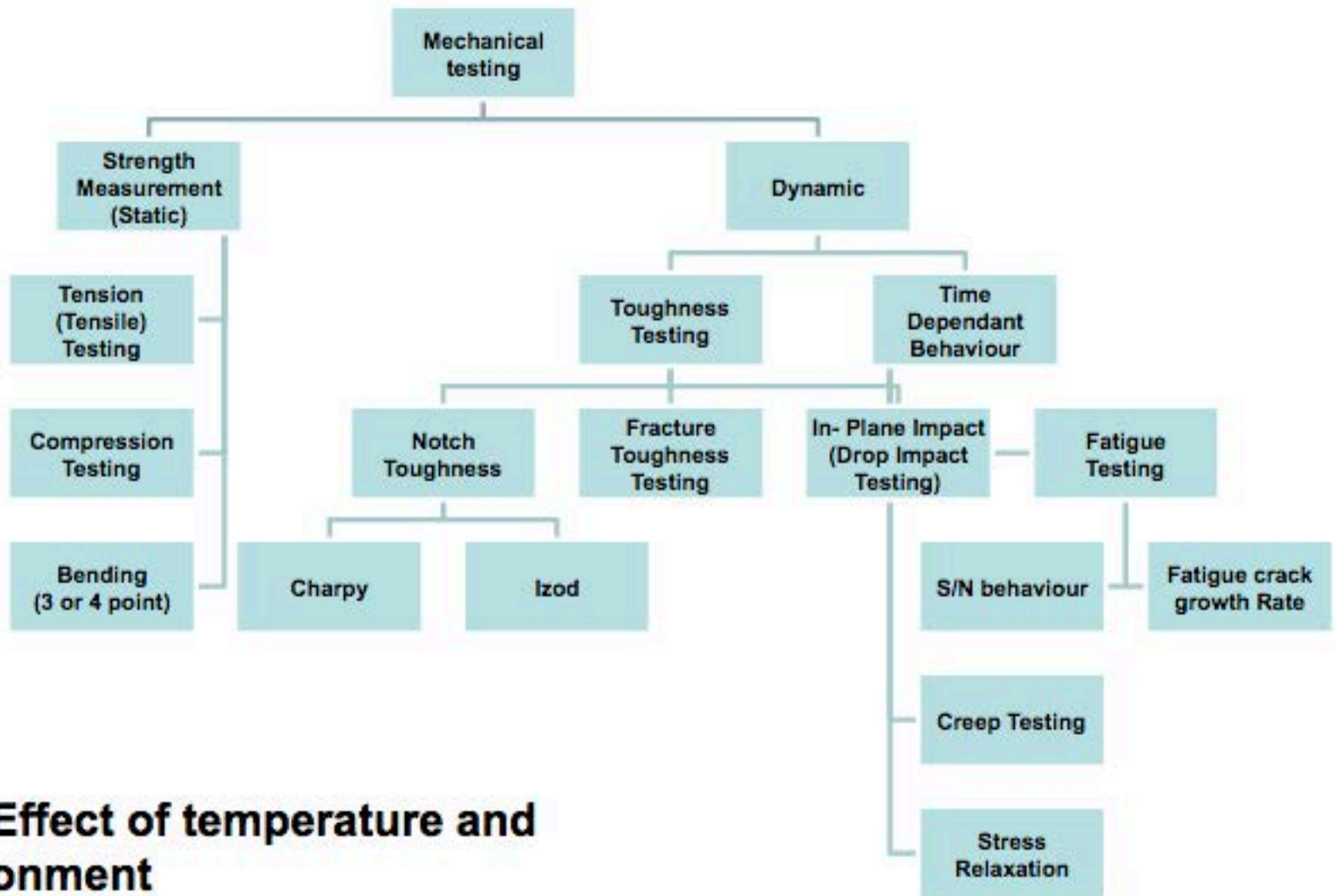
- ⊙ E , Young modulus
- ⊙ ν , Poisson modulus
- ⊙ G , Rigidity (shear) modulus
- ⊙ B , bulk modulus

- ⊙ $E = 2G(1 + \nu)$ $E = 3K(1 - 2\nu)$

- ⊙ $E = 9KG / (3K - G)$ $\nu = (3K - 2G) / (6K + 2G)$



Commonly Used Mechanical Testing Techniques

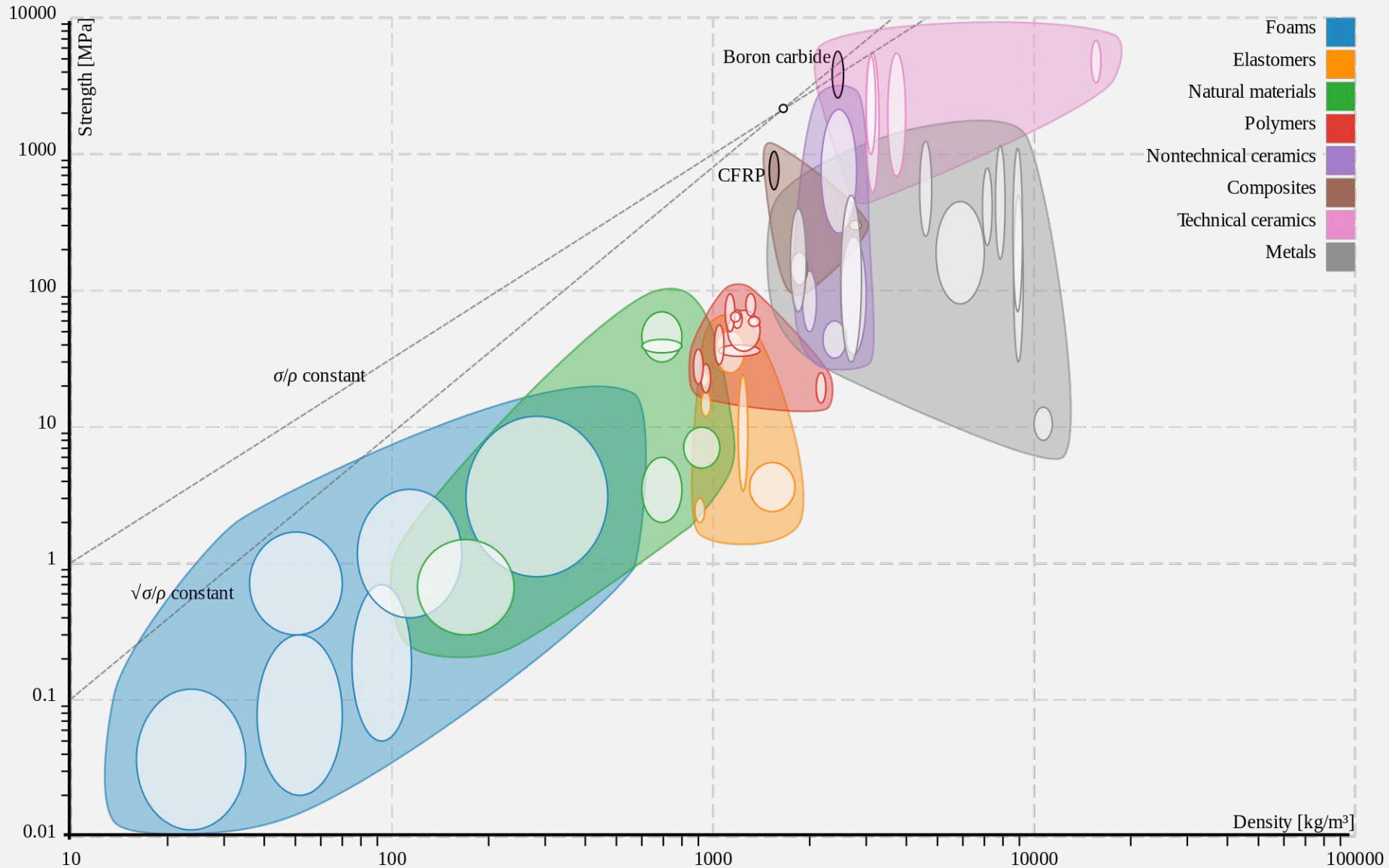


Strength



Tensile tests with and without liders behaviour
<https://www.youtube.com/watch?v=D8U4G5kcpcM>

Ashby map strength/density



Ashby map strength/density

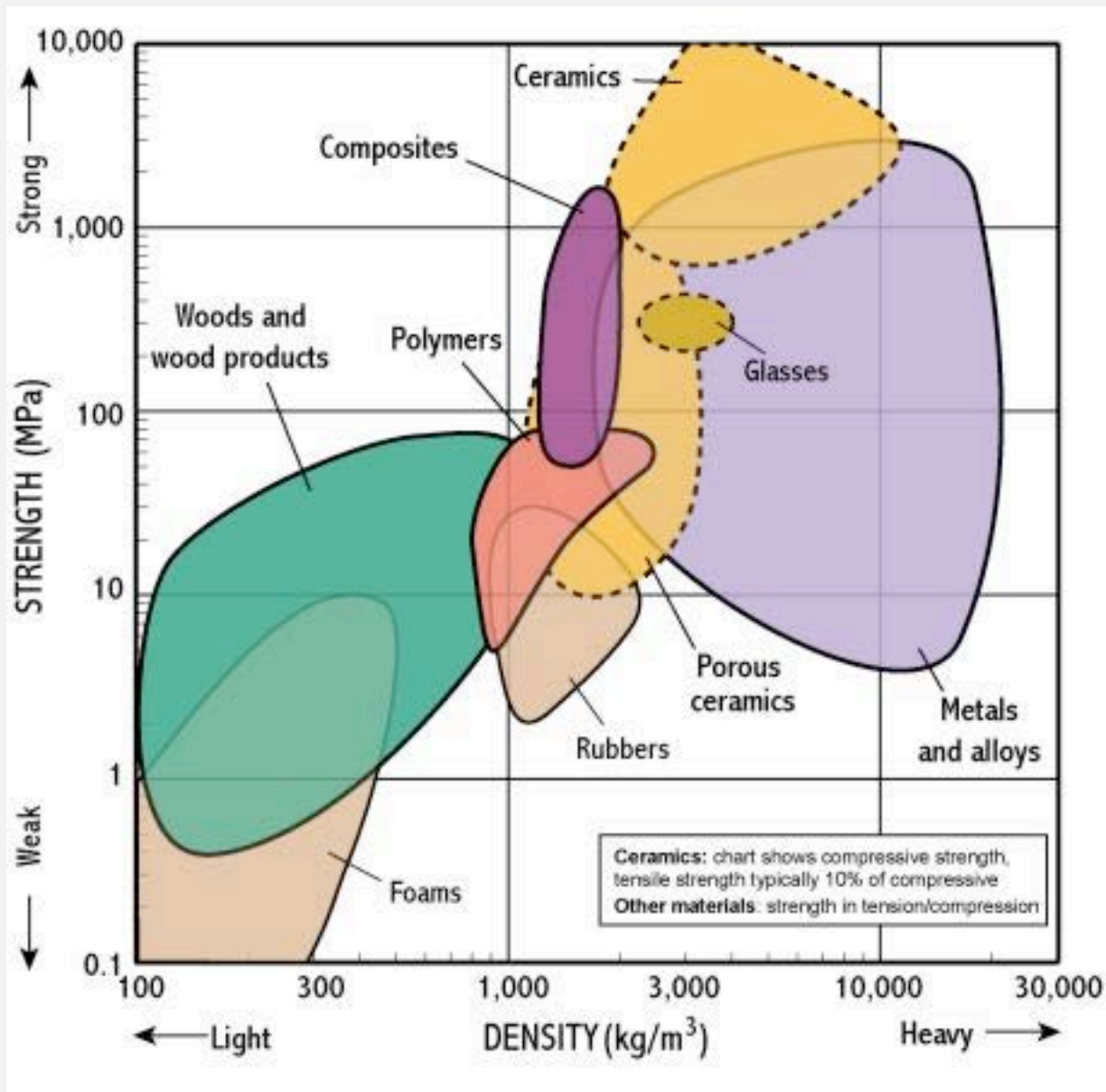
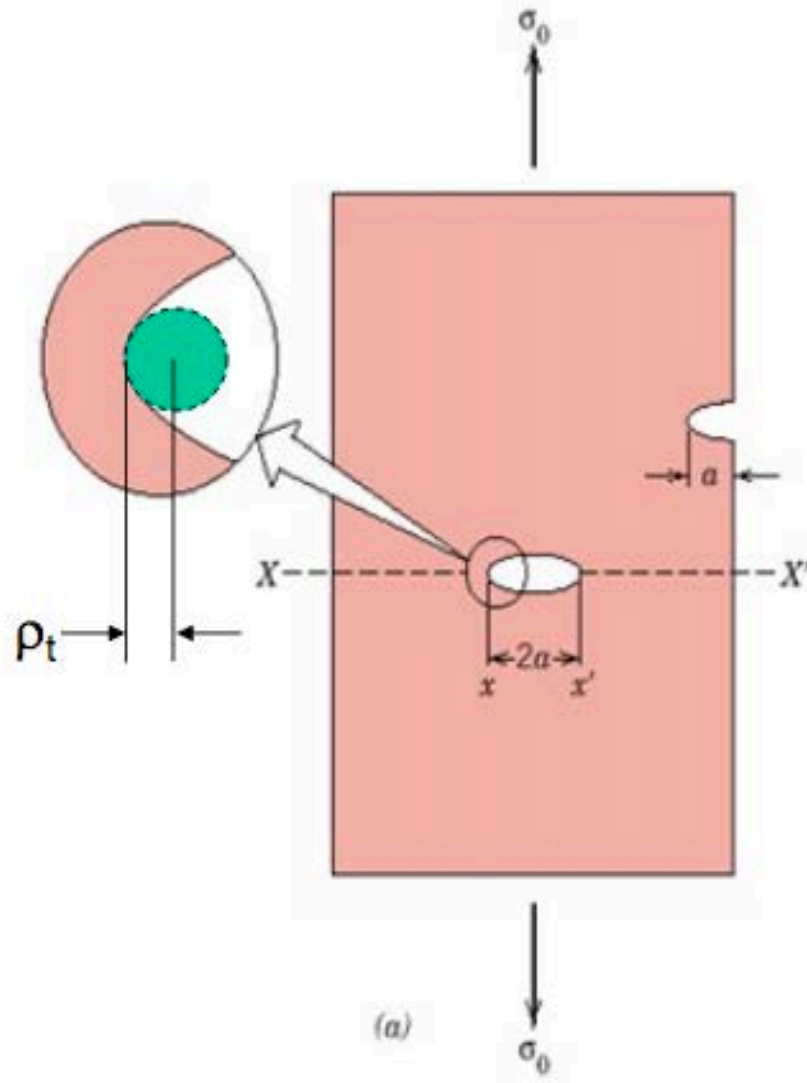


Table 5.3 Comparison of Theoretical Strength and Actual Strength

Material	E [GPa (psi)]	Estimated theoretical strength [GPa (psi)]	Measured strength of fibers [GPa (psi)]	Measured strength of polycrystalline specimen [GPa (psi)]
Al ₂ O ₃ ^a	380 (55 × 10 ⁶)	38 (5.5 × 10 ⁶)	16 (2.3 × 10 ⁶)	0.4 (60 × 10 ³)
SiC	440 (64 × 10 ⁶)	44 (6.4 × 10 ⁶)	21 (3.0 × 10 ⁶)	0.7 (100 × 10 ³)

^aFrom R. J. Stokes, *The Science of Ceramic Machining and Surface Finishing*, NBS Special Publication 348, U.S. Government Printing Office, Washington, D.C., 1972, p. 347.

Flaws are Stress Concentrators



If the crack is similar to an elliptical hole through plate, and is oriented perpendicular to applied stress, the **maximum stress σ_m** =

$$\sigma_m = 2\sigma_o \left(\frac{a}{\rho_t} \right)^{1/2} = K_t \sigma_o$$

where

ρ_t = radius of curvature

σ_o = applied stress

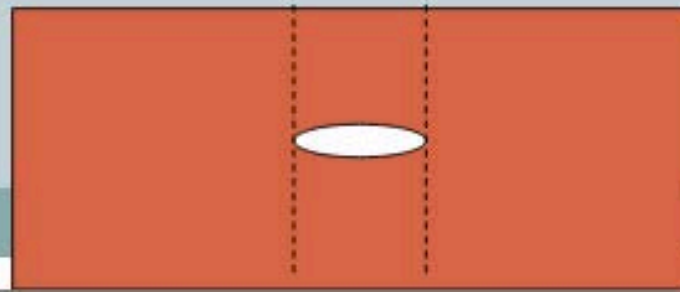
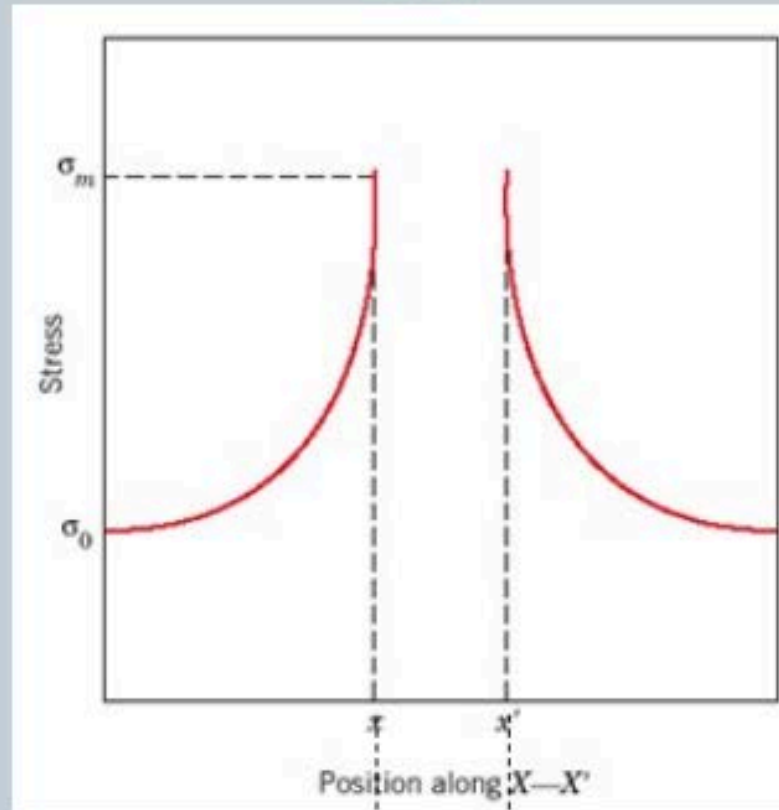
σ_m = **stress at crack tip**

a = length of surface crack or $\frac{1}{2}$ length of internal crack

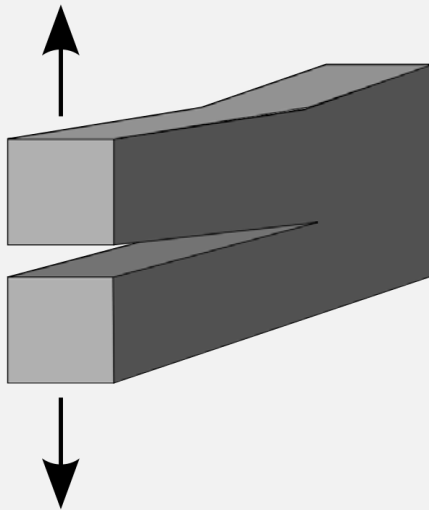
$\sigma_m / \sigma_o = K_t$ the stress concentration factor

Concentration of Stress at Crack Tip

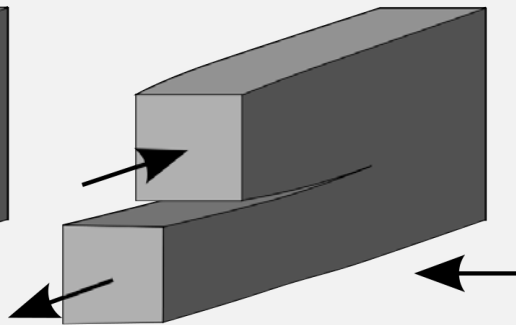
13



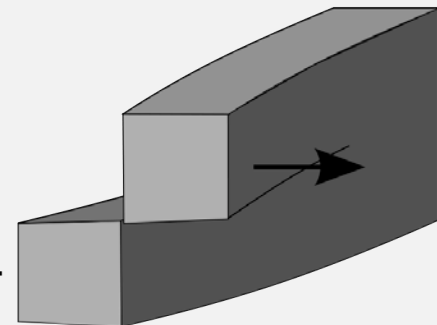
$$K = Y\sigma\sqrt{\pi a}$$



Mode I:
Opening

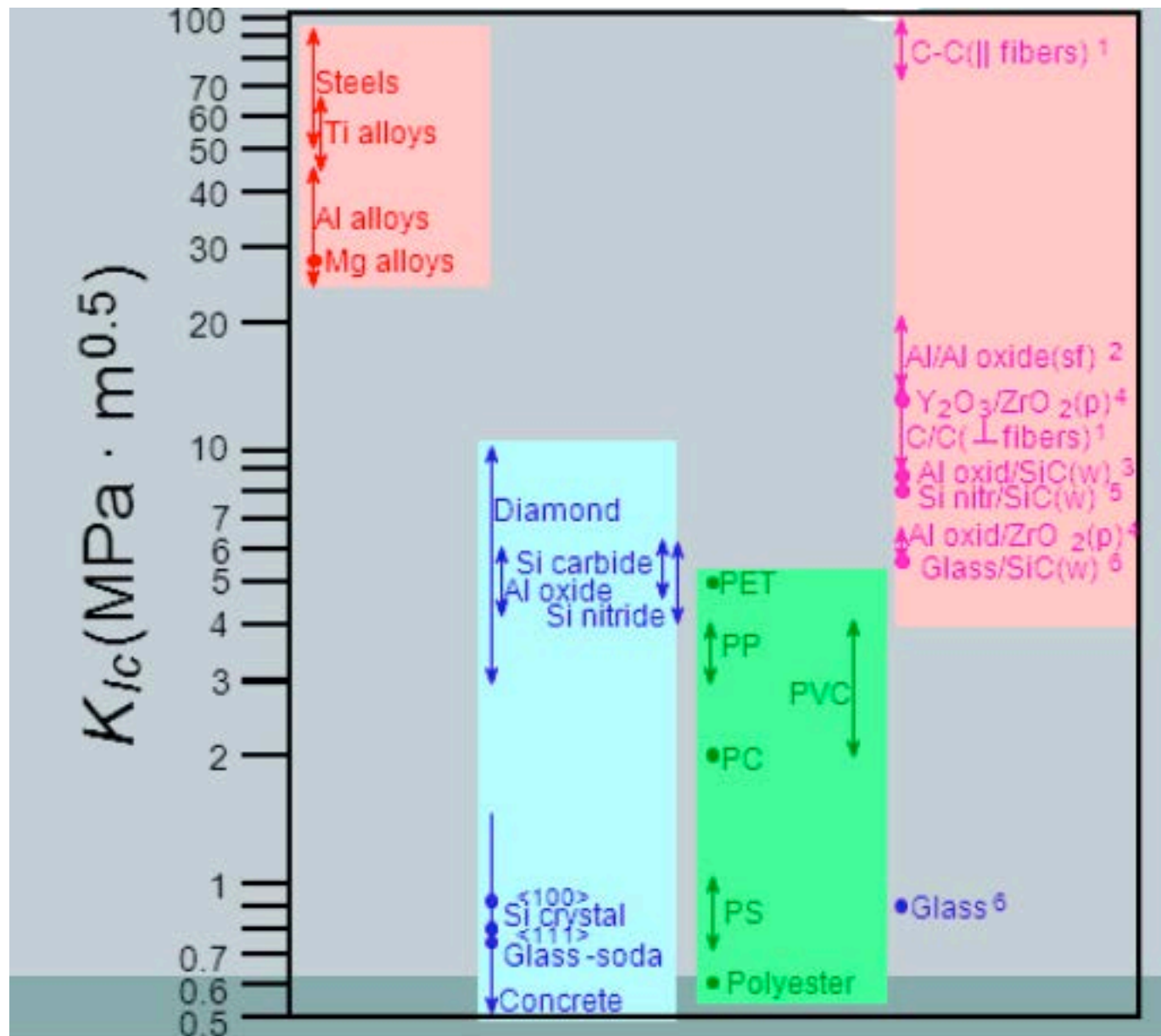


Mode II:
In-plane shear



Mode III:
Out-of-plane shear

$$K = Y\sigma\sqrt{\pi a}$$



DESIGN AGAINST CRACK GROWTH

- Crack growth condition: $K \geq K_c$

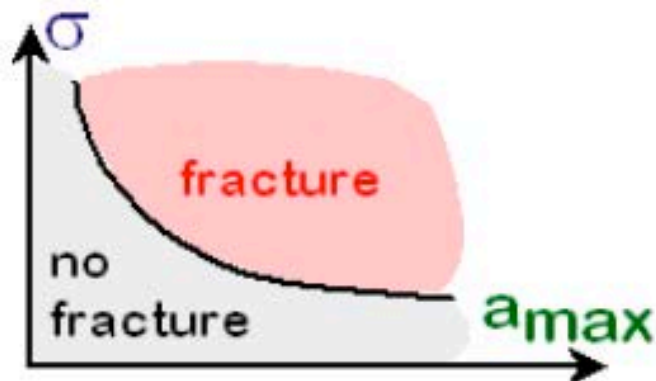
$$Y\sigma\sqrt{\pi a}$$

↗

- Largest**, most **stressed** cracks grow first.

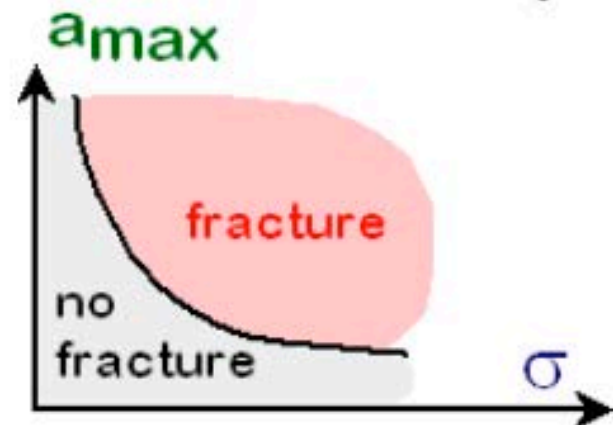
--Result 1: Max flaw size dictates design stress.

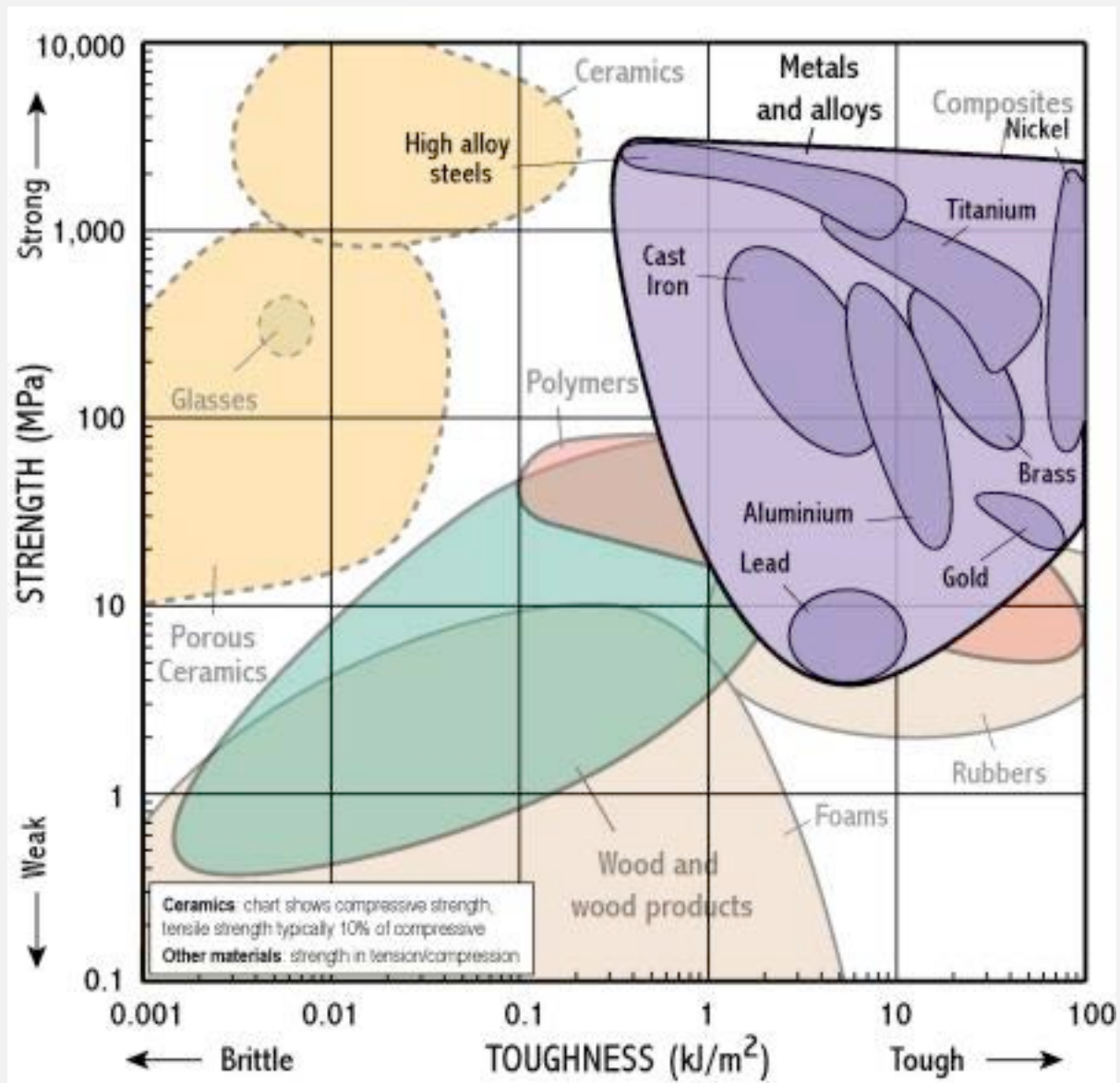
$$\sigma_{\text{design}} < \frac{K_c}{Y\sqrt{\pi a_{\text{max}}}}$$



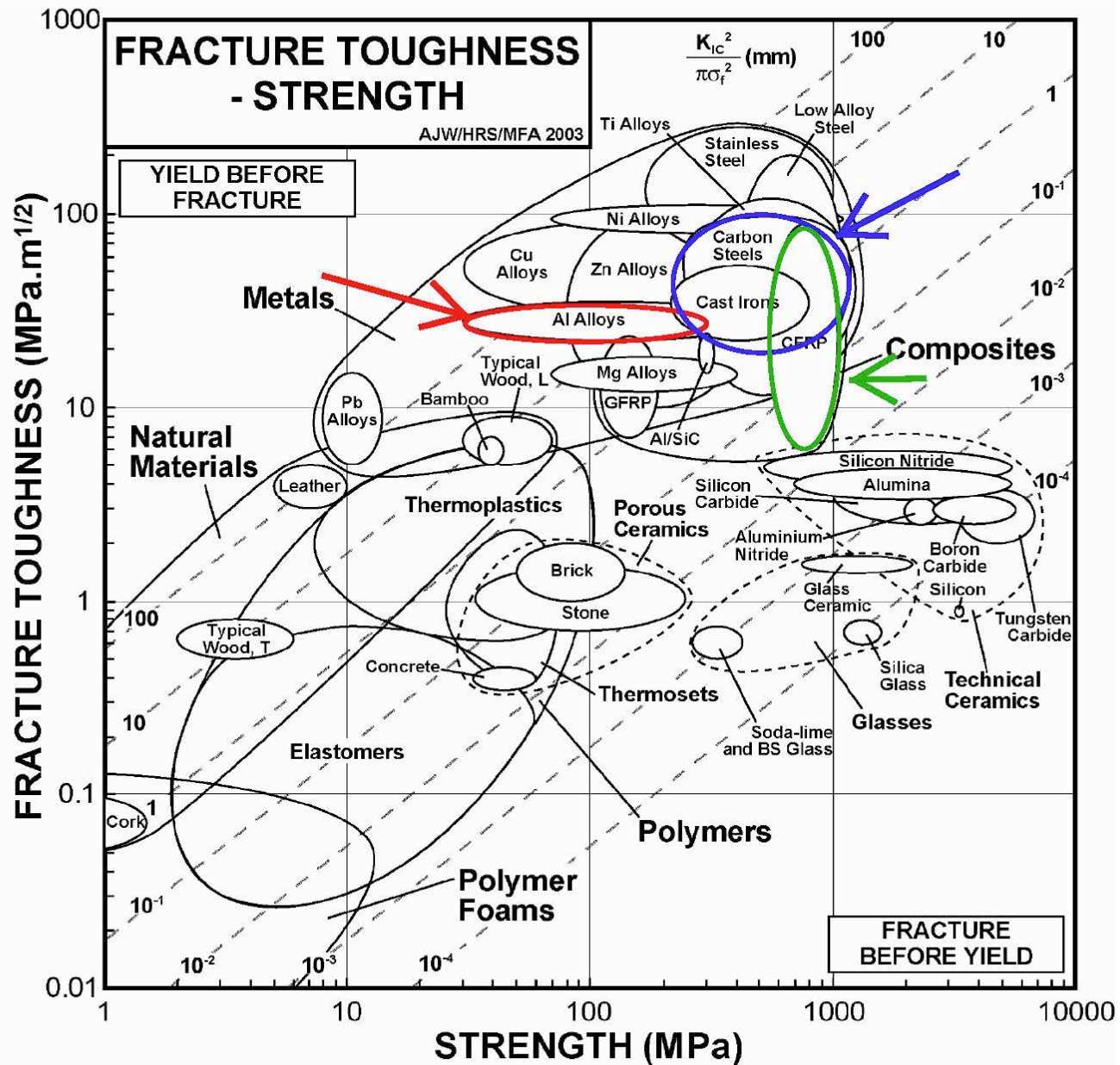
--Result 2: Design stress dictates max. flaw size.

$$a_{\text{max}} < \frac{1}{\pi} \left(\frac{K_c}{Y\sigma_{\text{design}}} \right)^2$$





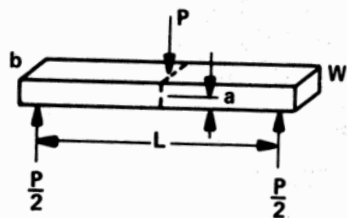
III.4 FRACTURE TOUGHNESS – STRENGTH



COMPARING CERAMICS AND METALS PART I

Property	Density (g/cm ³)	Elastic modulus (GPa)	Flexural strength (GPa)	Fracture toughness (MPa* m ^{1/2})	Max. service temperature (°C)
Aluminum oxide (sintered)	3.9	395	300	38	1,700
Zirconium oxide (sintered)	6.1	210	1,050	7	1,500
Silicon carbide (hot press)	3.1	400	380	3	1,600
Silicon nitride (Reaction bonded and sintered)	3.2	310	600	6	1,000
Boron nitride (hot press)	2.3	675	51	2.6	1,000
Silicon carbide (including fiber composite)	2.5	270	360	39	1,600
Advanced high-strength steel (QuesTek C61)	7.9	200	1,650	140	430

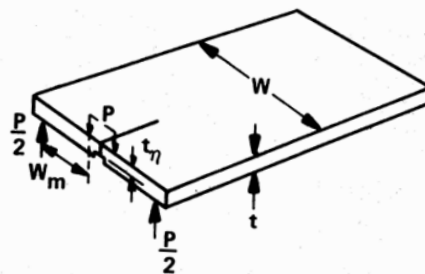
(a) SINGLE-EDGE NOTCHED BEAM (SENB) SPECIMEN



$$K_I = Y \frac{3PL}{2bW^2} \sqrt{a}$$

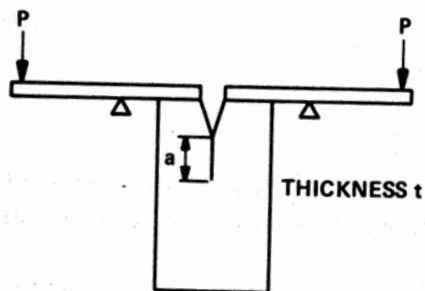
$$Y = 1.96 - 2.75 \left(\frac{a}{W} \right) + 13.66 \left(\frac{a}{W} \right)^2 - 23.98 \left(\frac{a}{W} \right)^3 + 25.22 \left(\frac{a}{W} \right)^4$$

(b) DOUBLE TORSION (DT) SPECIMEN



$$K_I = PW_m \left[\frac{3(1+\nu)}{Wt^3t_\eta} \right]^{1/2}$$

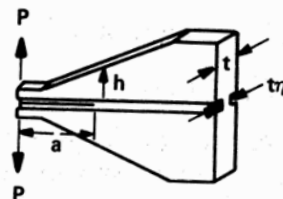
(c) CONSTANT-MOMENT SPECIMEN



$$K_I = \frac{\text{MOMENT}}{\sqrt{It}}$$

I IS INERTIA OF ONE ARM.

(d) TAPERED DOUBLE CANTILEVER BEAM (TCB) SPECIMEN

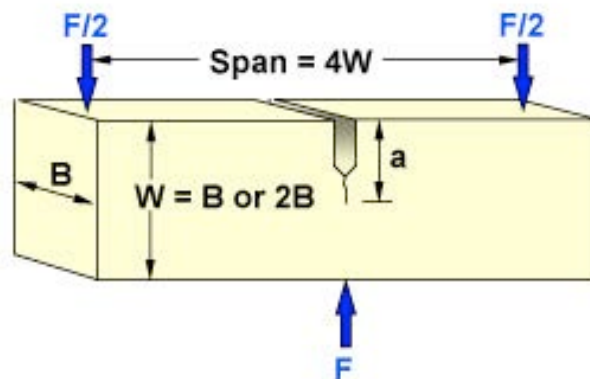


$$K_I = 2P \left(\frac{m}{tt_\eta} \right)$$

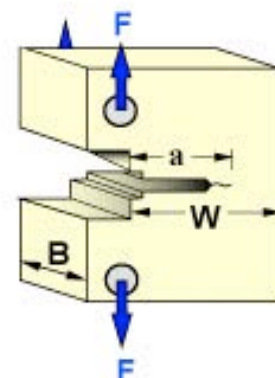
$$M = \frac{1}{t}$$

Accurate
determinations of K_{Ic}

SENB Specimen



CT Specimen



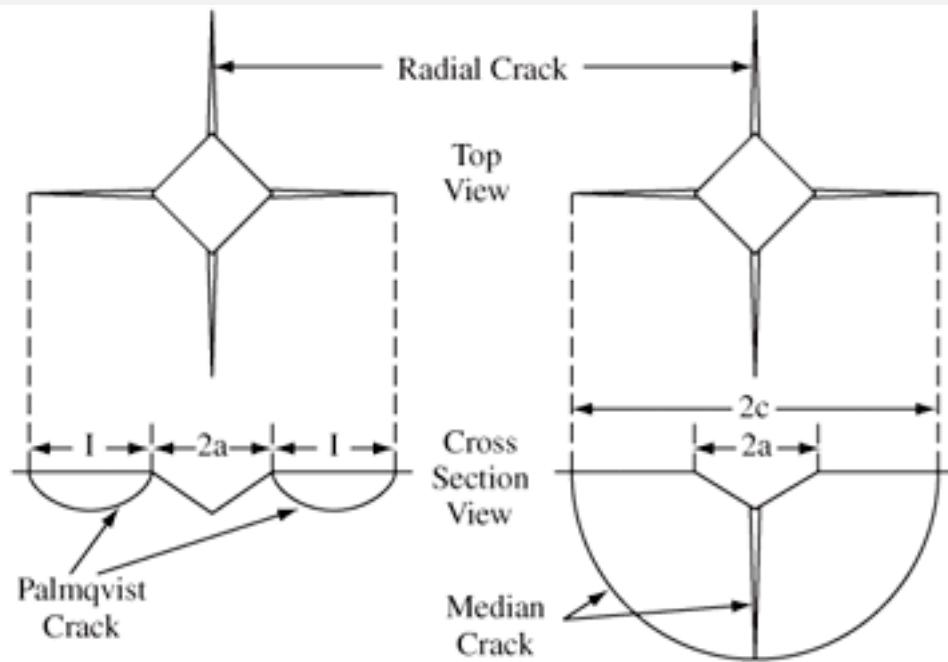


Figure 1. Crack formation by Vickers indentation.

$$K_c = 0,016 \left(\frac{E}{H_V} \right)^{0,5} \frac{P}{c^{1,5}}$$

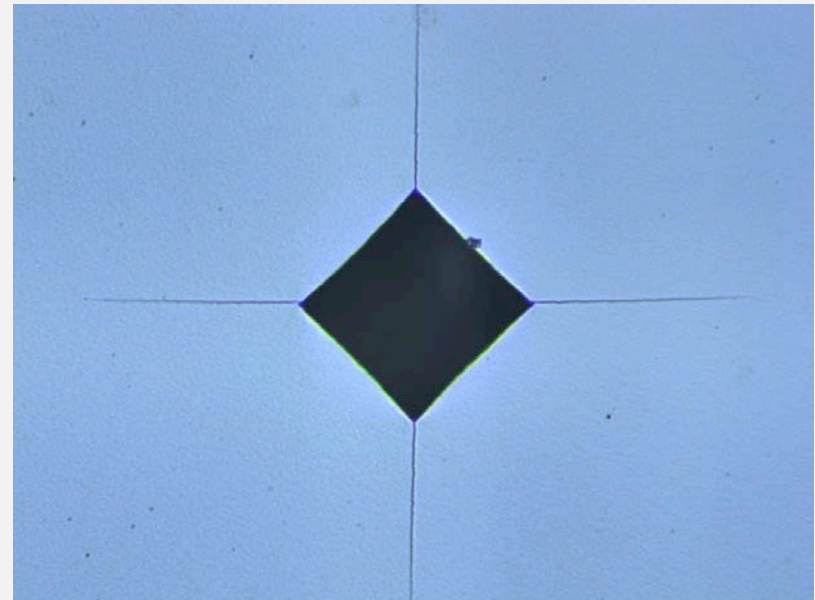


Table I. Materials Used in Indentation Toughness Studies

Material	Characterization	(μm)	Grain size E (GPa)	H (GPa)	K_{IC} (MPa $\cdot\text{m}^{1/2}$)	Toughness measurement ^g
Glass-ceramic (C9606) ^a	Glass-ceramic	1	108	8.4	2.5	DCB (standard)
Soda-lime glass I ^b	Amorphous		70	5.5	0.74	DCB (standard)
Soda-lime glass II ^c	Amorphous		73	5.6	0.75	DCB (standard) (Ref. 27)
Aluminosilicate glass ^c	Amorphous		89	6.6	0.91	DCB (standard) (Ref. 27)
Lead alkali glass ^c	Amorphous		65	4.9	0.68	DCB (standard) (Ref. 27)
Al ₂ O ₃ (AD999) ^d	Polycrystal	3	406	20.1	3.9	DCB (standard)
Al ₂ O ₃ (AD90) ^d	Polycrystal	4	390	13.1	2.9	DCB (standard)
Al ₂ O ₃ (Vi) ^e	Polycrystal	20	305	19.1	4.6	DCB (D. B. Marshall)
Al ₂ O ₃ (sapphire) ^f	Monocrystal ^g		425	21.8	2.1	DT (A. G. Evans ^h and E. A. Charles, ^h Ref. 20)
Si ₃ N ₄ (NC132) ^g	Polycrystal	2	300	18.5	4.0	DCB (standard)
Si ₃ N ₄ (NC350) ^g	Polycrystal	10	170	9.6	2.0	DT (S. M. Wiederhorn ^h and N. J. Tighe ^h)
SiC (NC203) ^g	Polycrystal	4	436	24.0	4.0	DT (S. M. Wiederhorn ^h and N. J. Tighe ^h)
ZrO (Ca-stabilized) ^h	Polycrystal	50	210	10.0	7.6	DCB (D. B. Marshall)
Si ⁱ	Monocrystal ^k		168	10.6	0.7	DT (S. M. Wiederhorn ^h and E. R. Fuller ^h)
WC (Co-bonded) ^c	Polycrystal	3	575	13.2	12	DT (S. W. Freiman ^h)

^aPyroceram, Corning Glass Works, Corning, N. Y. ^bCommercial sheet glass. ^cNational Bureau of Standards, Washington, D. C. ^dCoors Porcelain Co., Golden, Colo. ^eVistal, Coors Porcelain Co. ^fLinde, Union Carbide Co., New York, N. Y. ^gNorton Co., Worcester, Mass. ^hCSIRO, Australia. ⁱTexas Instruments, Inc., Dallas. ^jRods, [0001] 30° to axis. ^kDisks, [111] parallel to axis. ^lDT=double torsion, DCB=double cantilever beam. ^mUniversity of California, Berkeley. ⁿRockwell International Science Center, Thousand Oaks, Calif. ^oNational Bureau of Standards.

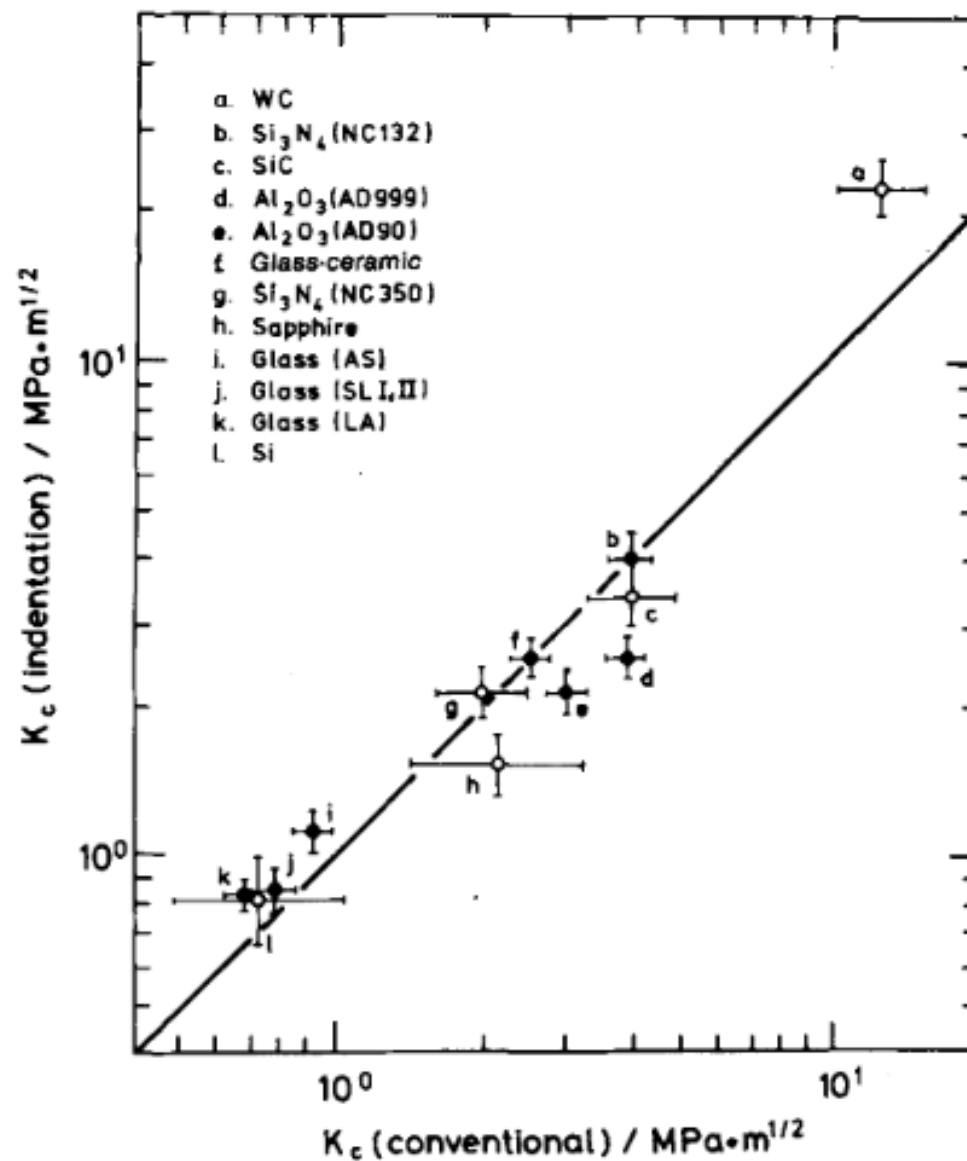
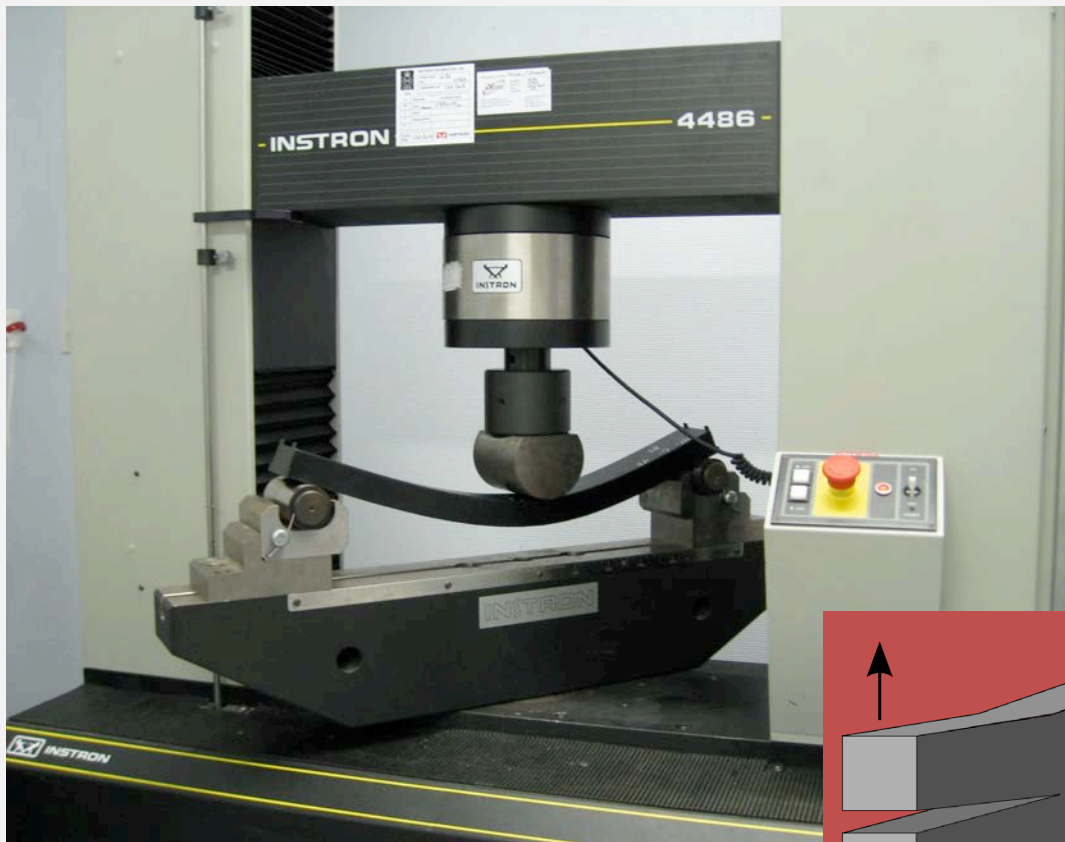
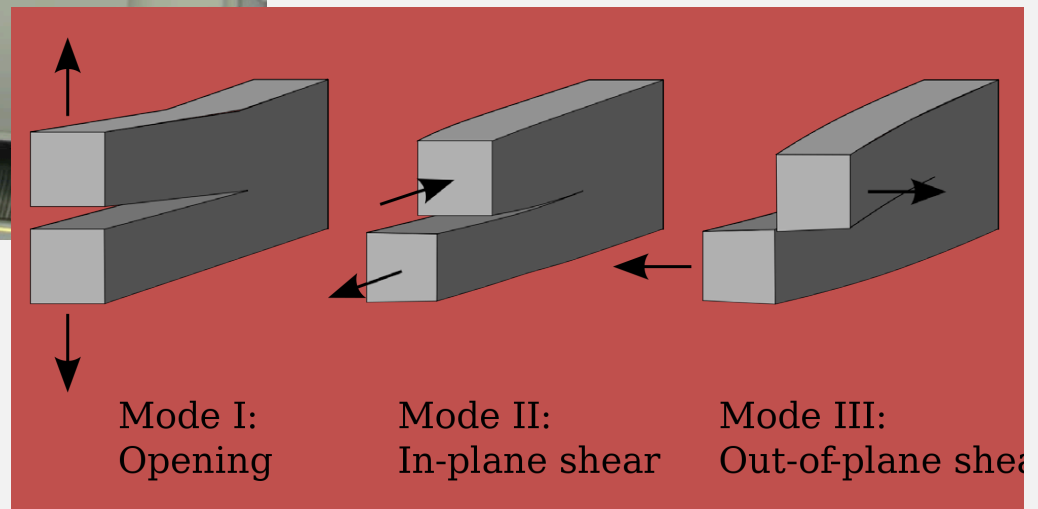


Fig. 5. Plot demonstrating correlation between toughness values determined by indentation and by conventional means. Filled symbols denote reference materials used to evaluate constant ξ_0^R in Eq. (4). Vertical error bars represent uncertainty (standard deviation) in parameter $P/c_0^{3/2}$ obtained from Fig. 4, horizontal error bars nominal accuracy of K_c values taken from Table I.

ISB determination of K_{Ic}

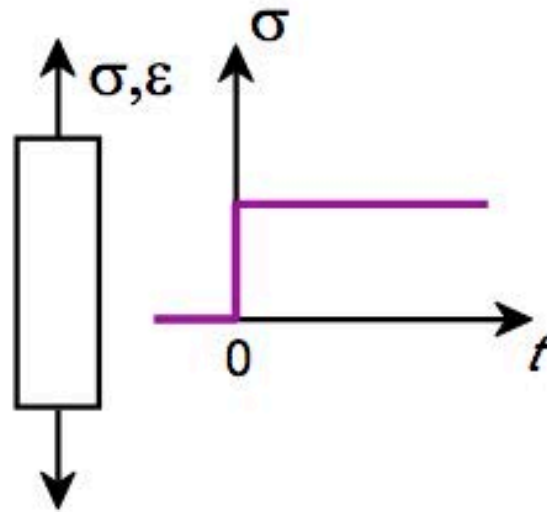


$$K_{Ic} = 0,59 \cdot \left(\frac{E}{H_v} \right)^{\frac{1}{8}} \cdot \left(\sigma_f \cdot p^{\frac{1}{3}} \right)^{\frac{3}{4}}$$



Creep

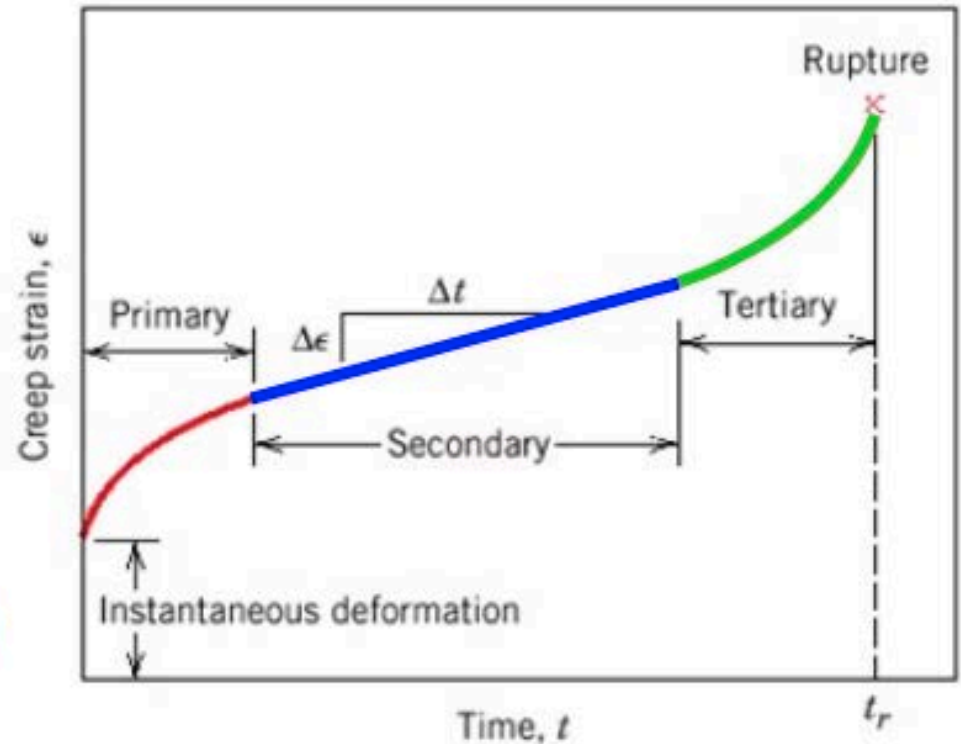
Sample deformation at a constant stress (σ) vs. time



Primary Creep: slope (creep rate) decreases with time.

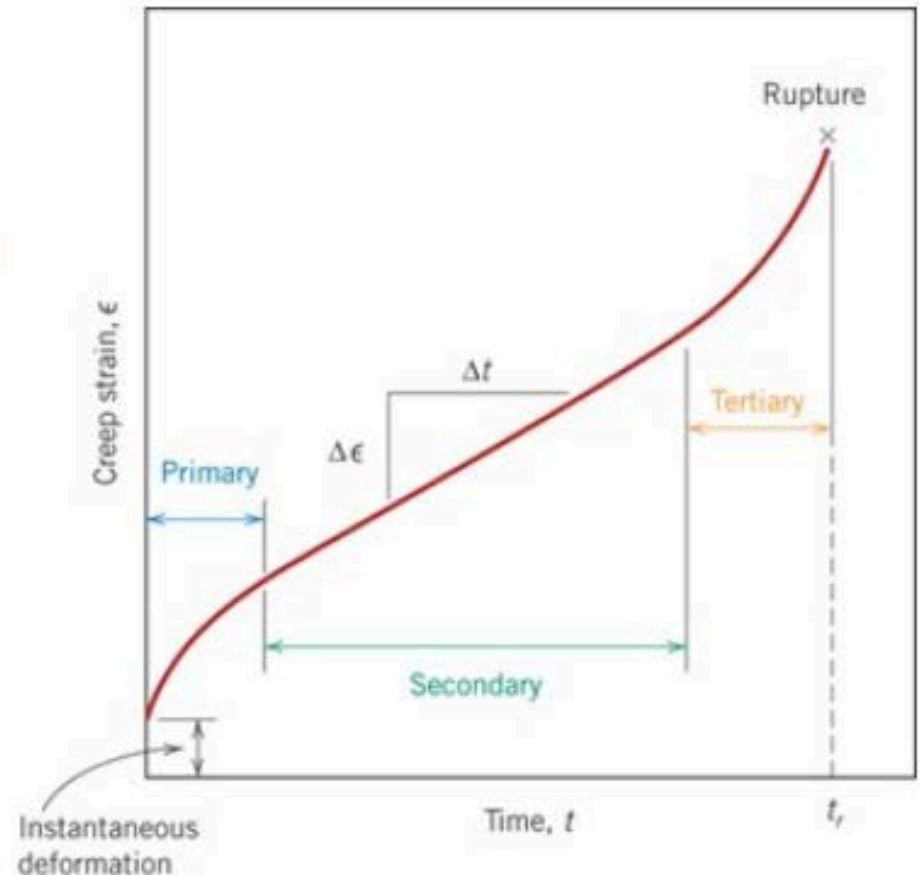
Secondary Creep: steady-state i.e., constant slope.

Tertiary Creep: slope (creep rate) increases with time, i.e. acceleration of rate.



Creep

- A typical creep test consists of subjecting a specimen to a constant load or stress while maintaining constant temperature.
- Upon loading, there is instant elastic deformation. The resulting creep curve consists of 3 regions: **primary or transient** creep adjusts to the creep level (creep rate may decrease); **secondary creep**-steady state-constant creep rate, fairly linear region (strain hardening and recovery stage); **tertiary creep**, there is accelerated rate of strain until rupture (grain boundary separation, internal crack formation, cavities and voids).



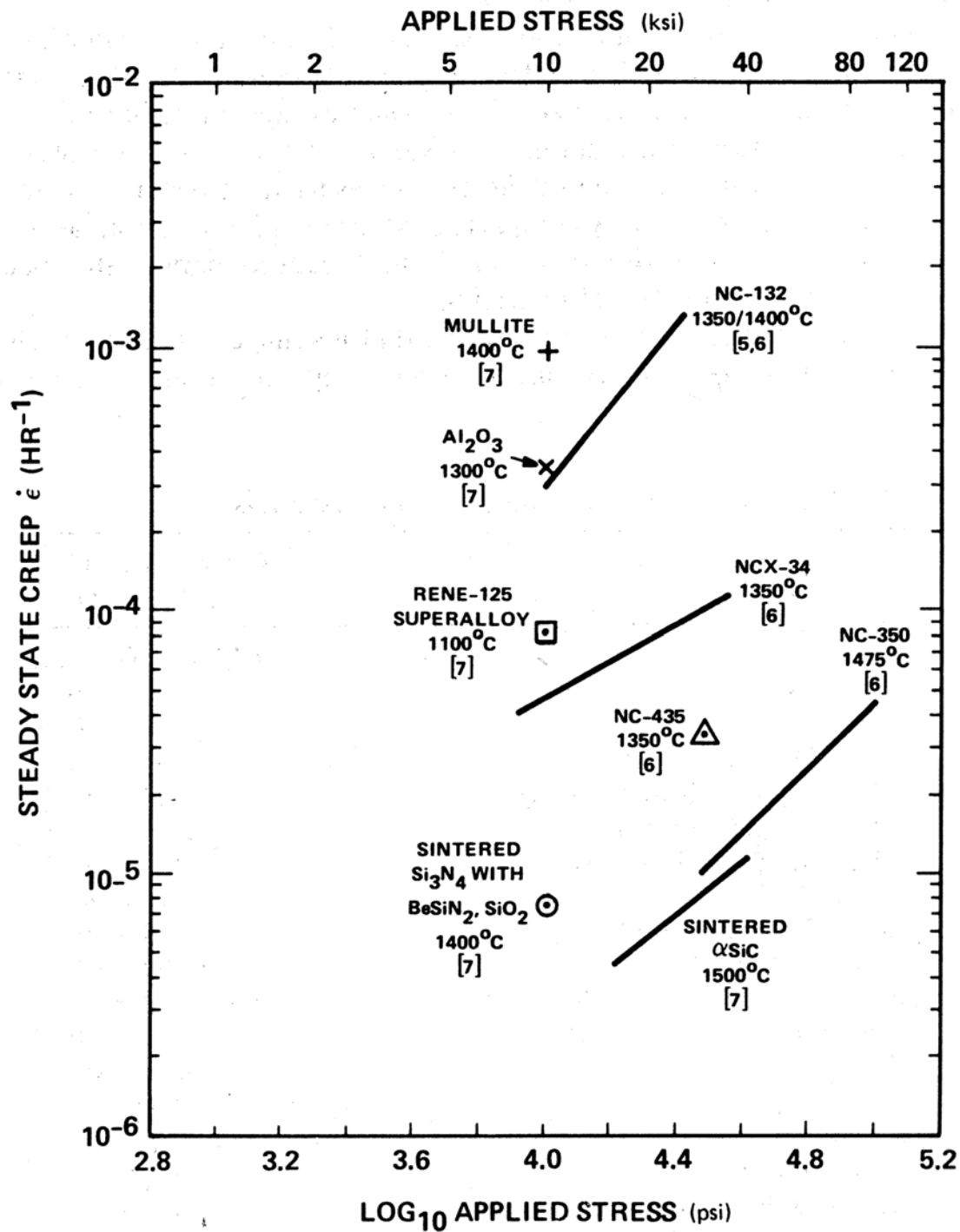
Creep strain vs time at constant load and constant elevated temperature. Minimum creep rate (**steady-state creep rate**), is the slope of the linear segment in the secondary region. Rupture lifetime t_r is the total time to rupture.

Secondary Creep

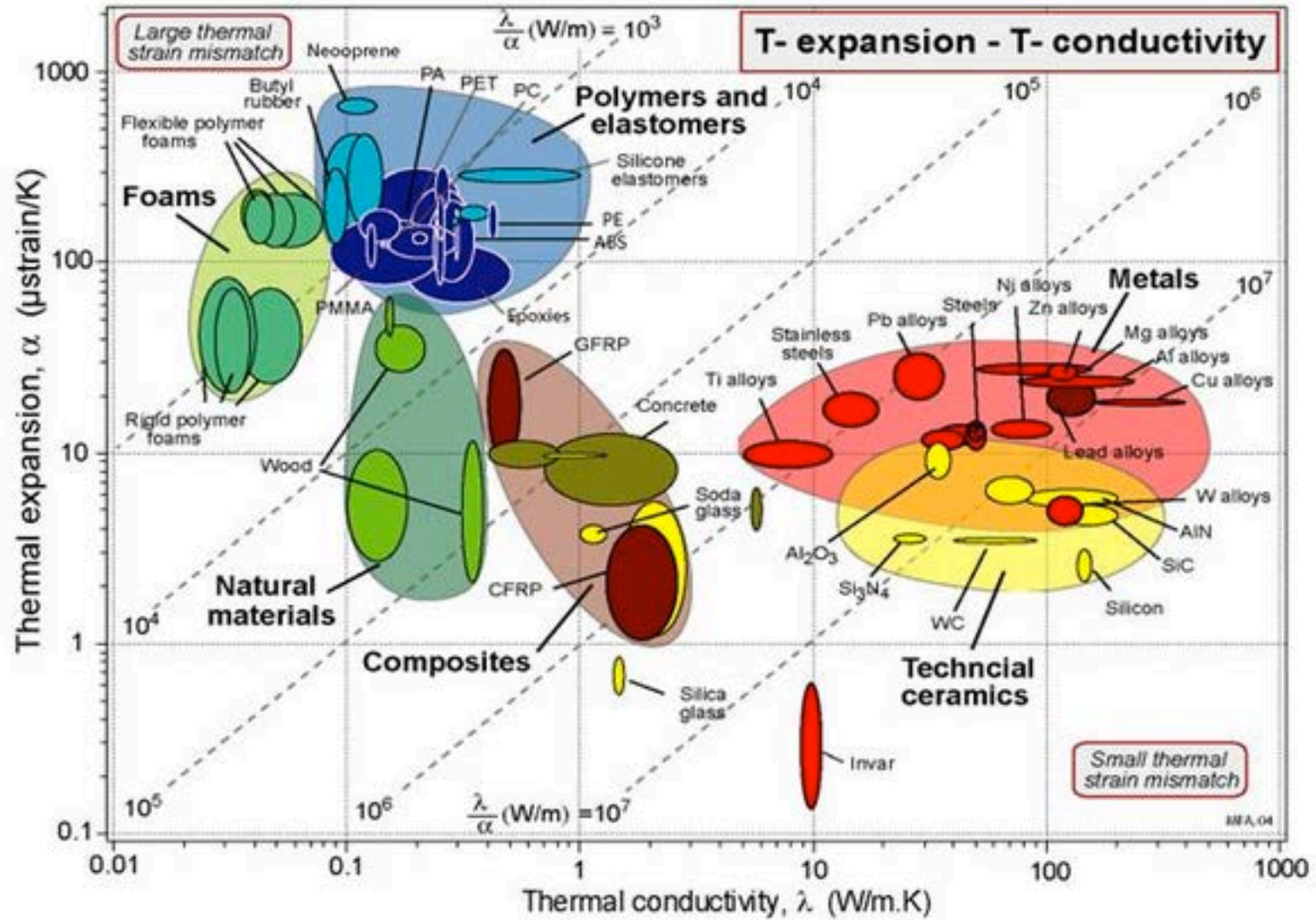
- Strain rate is constant at a given T, σ
 - strain hardening is balanced by recovery

The diagram shows the equation for secondary creep: $\dot{\epsilon}_s = K_2 \sigma^n \exp\left(-\frac{Q_c}{RT}\right)$. The terms are labeled as follows:

- $\dot{\epsilon}_s$ (blue box): strain rate
- K_2 (black text): material const.
- σ (green box): applied stress
- n (green text): stress exponent (material parameter)
- Q_c (red box): activation energy for creep (material parameter)



Ashby map Therm. Expan./therm Conduc



Thermal shock resistance

Table 8.8 Calculated Values of the Thermal Shock Parameter R for Various Ceramic Materials Using Typical Property Data

Material	Strength, ^a σ (psi)	Poisson's Ratio, ν	Thermal Expansion, α (in./in. · °C)	Elastic Modulus, E (psi)	$R = \frac{\sigma(1 - \nu)}{\alpha E}$ (°C)
Al ₂ O ₃	50,000	0.22	7.4×10^{-6}	55×10^6	96
SiC	60,000	0.17	3.8×10^{-6}	58×10^6	230
RSSN ^b	45,000	0.24	2.4×10^{-6}	25×10^6	570
HPSN ^b	100,000	0.27	2.5×10^{-6}	45×10^6	650
LAS ^b	20,000	0.27	-0.3×10^{-6}	10×10^6	4860

^aFlexure strength used rather than tensile strength.

^bRSSN, reaction-sintered silicon nitride; HPSN, hot-pressed silicon nitride; LAS, lithium aluminum silicate (β -spodumene).

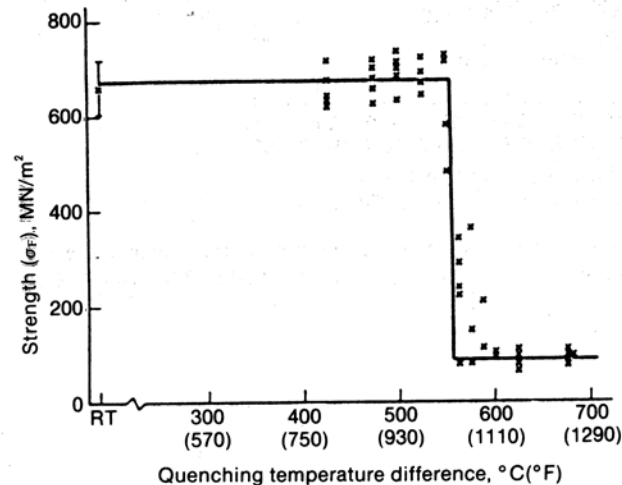


Figure 8.32 Typical results of retained strength versus thermal shock ΔT for quench test. Example is for hot-pressed Si₃N₄ material containing 3% MgO as a densification aid. (From G. Ziegler, in *Progress in Nitrogen Ceramics* [F. L. Riley, ed.] Martinus Nijhoff Publishers, The Hague, 1983.)

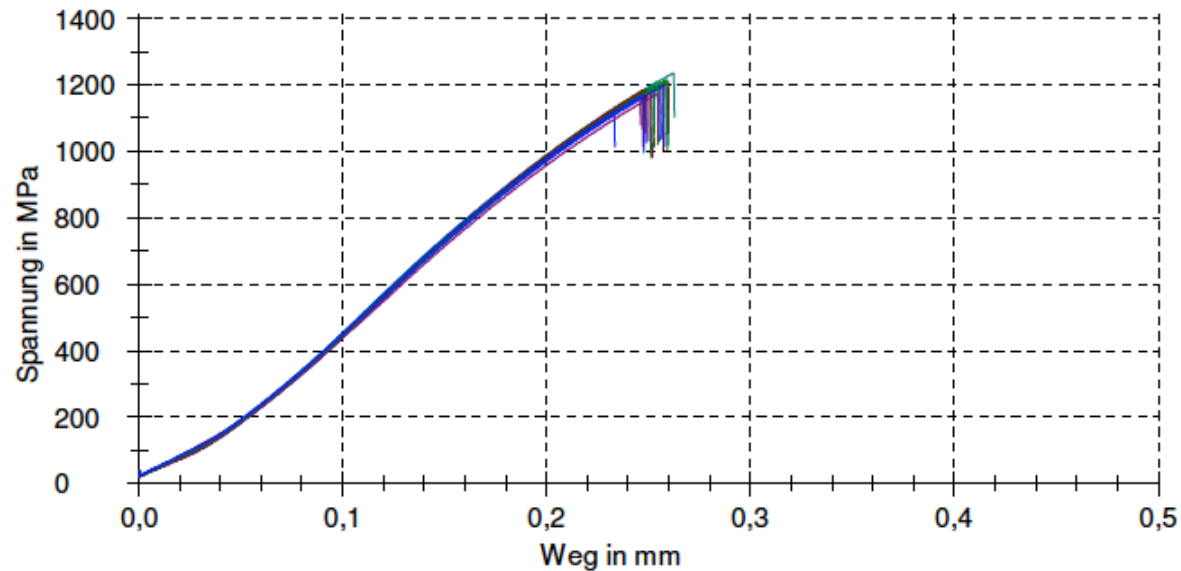
Stress data for Weibull plot

Ergebnisse:

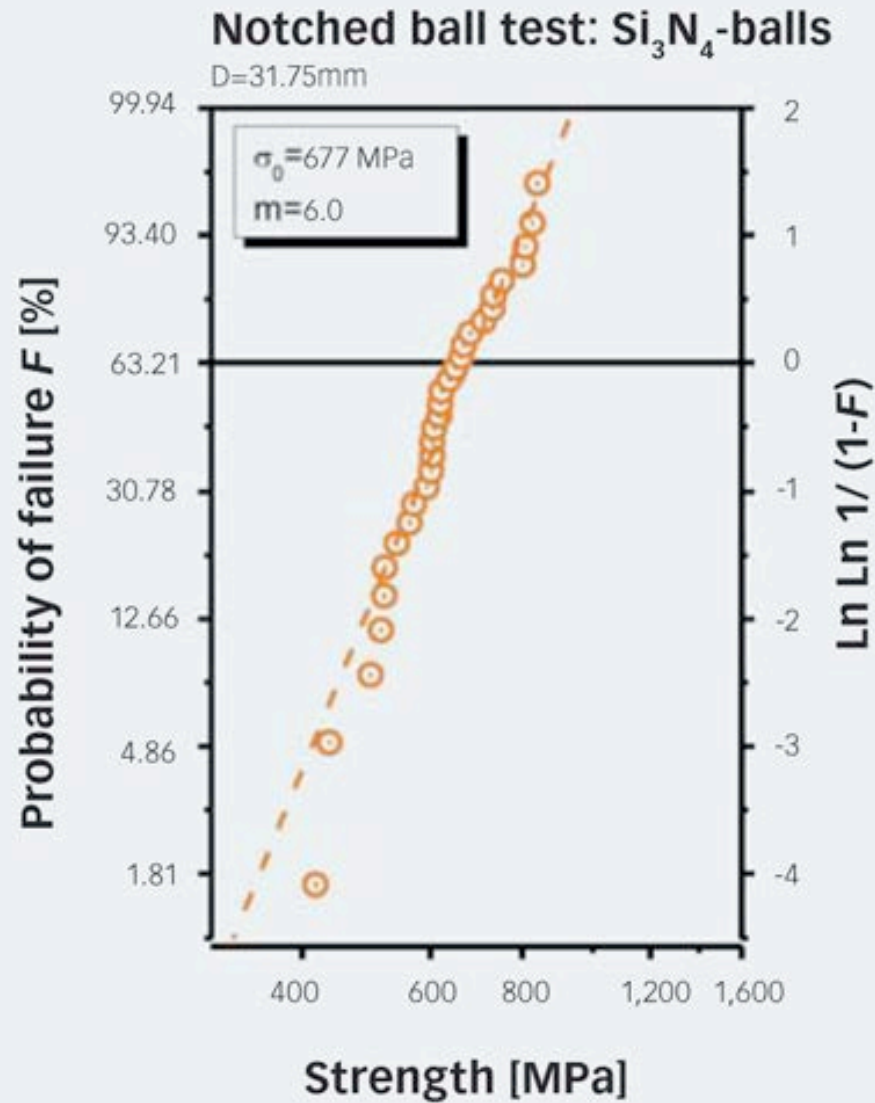
Nr	P N	σ MPa	P _r	d mm	r3 mm
1	998,3	1190	0,00	1,185	6,735
2	993,3	1190	0,00	1,181	6,875
3	1034,9	1200	0,00	1,2	6,895
4	994,4	1190	0,00	1,181	6,88
5	1002,2	1180	0,00	1,192	6,935
6	1026,4	1210	0,00	1,192	6,9
7	1035,1	1210	0,00	1,194	6,915
8	940,4	1120	0,00	1,184	6,9
9	1026,8	1190	0,00	1,199	6,935
10	1000,4	1180	0,00	1,192	6,935
11	971,5	1170	0,00	1,176	6,945
12	993,2	1190	0,00	1,183	6,885

Nr	P N	σ MPa	P _r	d mm	r3 mm
13	1013,2	1200	0,00	1,19	6,885
14	1018,6	1210	0,00	1,185	6,945
15	994,4	1180	0,00	1,189	6,9
16	980,9	1170	-	1,186	6,9
17	1016,7	1210	-	1,186	6,92
18	992,1	1170	-	1,191	6,945
19	1033,9	1240	-	1,184	6,865
20	989,6	1170	-	1,188	6,88
21	998,7	1190	-	1,187	6,94
22	1025,5	1210	-	1,19	6,895
23	985,1	1170	-	1,188	6,915

Seriengrafik:



Data from SKF



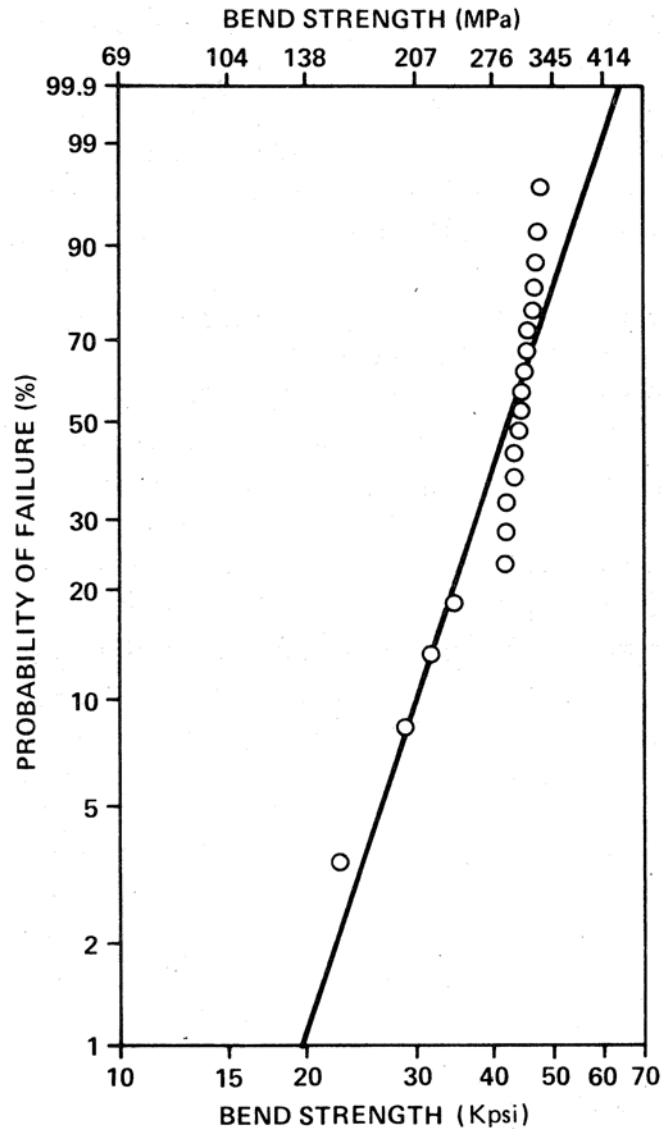


Figure 15.6 Example of Weibull curve generated from strength test data for reaction-bonded Si_3N_4 . (Data from Ref. 6.)

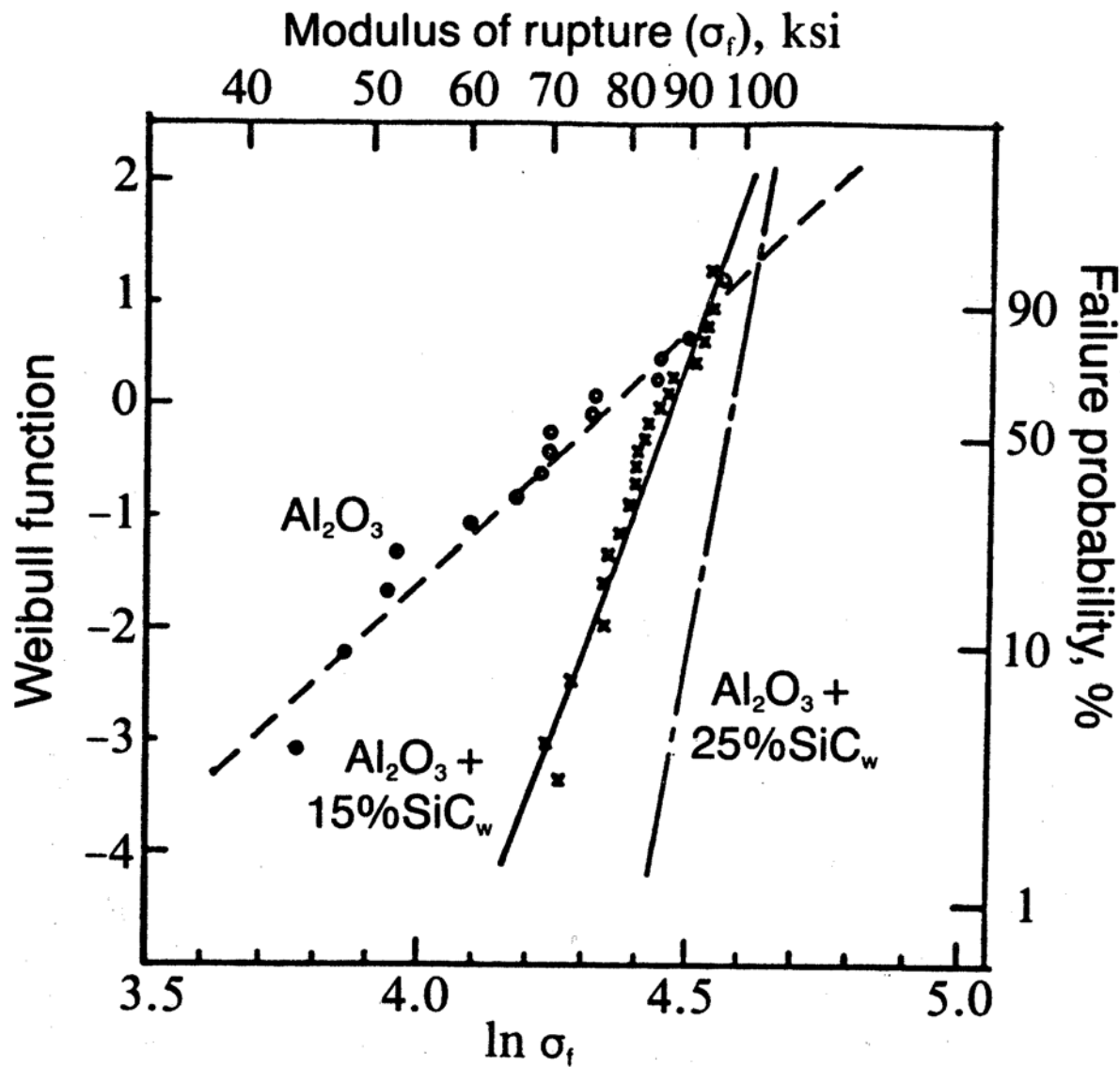


Figure 15.8 Example of the use of Weibull plots to compare material. (Adapted from J.F. Rhodes, H.M. Rootare, C.A. Springs, and J.E. Peters, data presented at the 88th Annual Meeting of the American Ceramic Society, Chicago, Ill. April 28, 1986.)

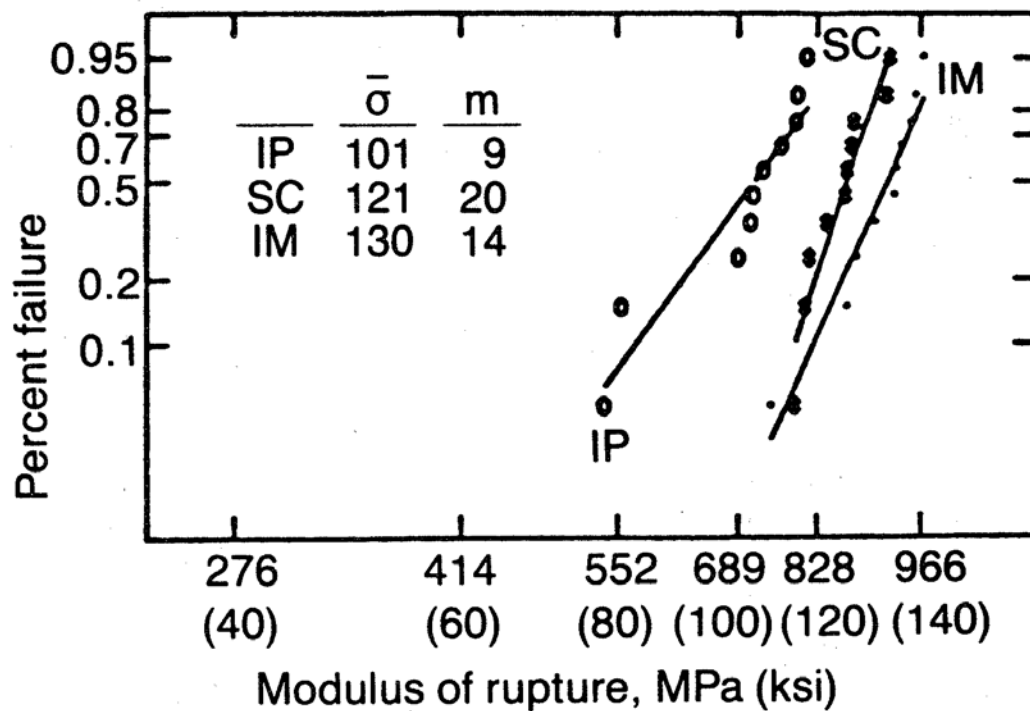


Figure 15.10 Weibull plots comparing the strength of a sintered Si_3N_4 fabricated by various techniques. IP is isostatically pressed, SC is slip-cast, and IM is injection-molded. (From A. Pasto, J. Neil, and C.L. Quackenbush, paper presented at International Conference on Ultrastructure Processing of Ceramics, Glasses and Composites, Gainesville, Florida, Feb. 13–17, 1983.)

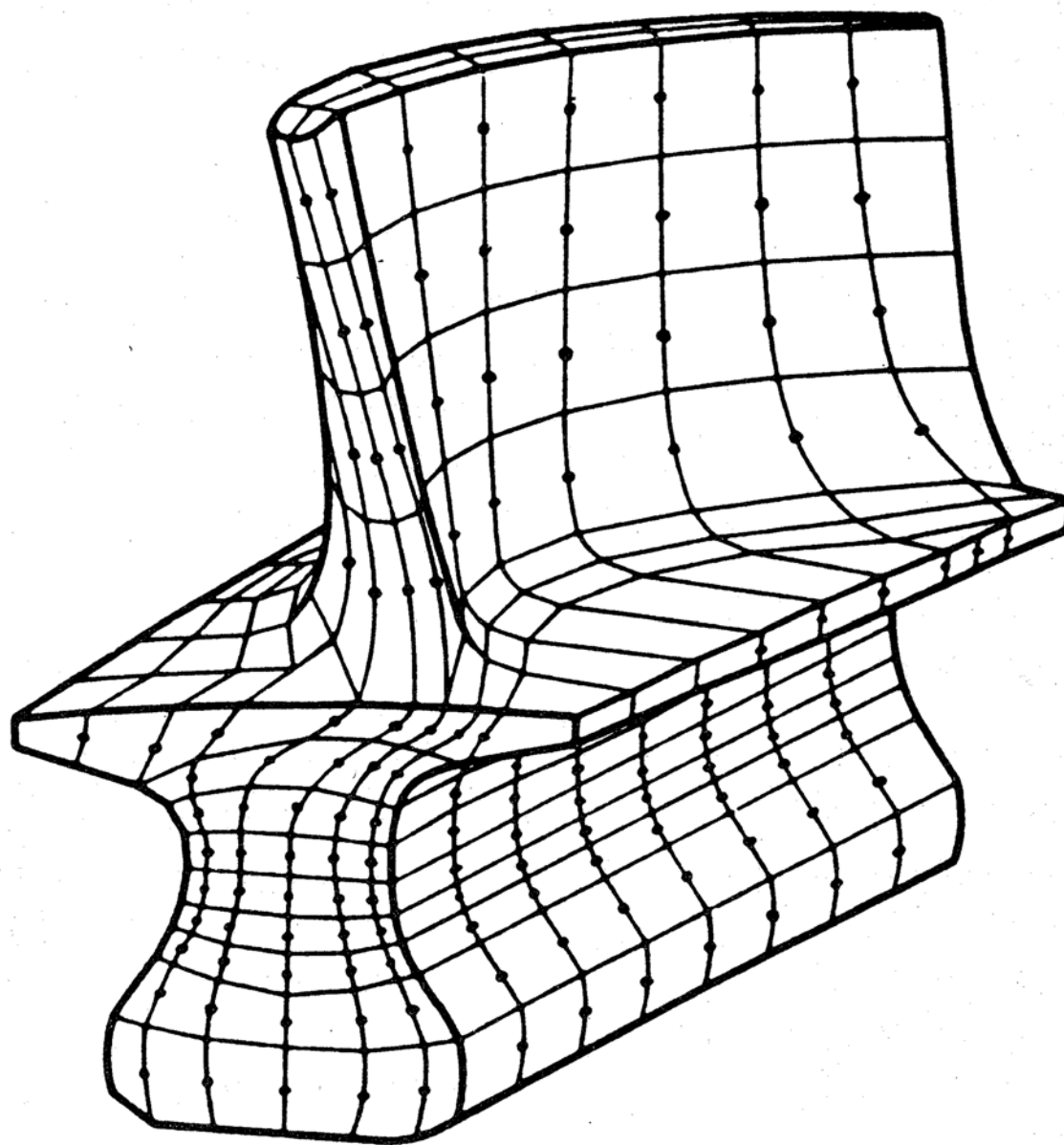


Figure 15.11 Finite-element analysis model for a ceramic rotor blade for a gas-turbine engine. (© ASM International.)

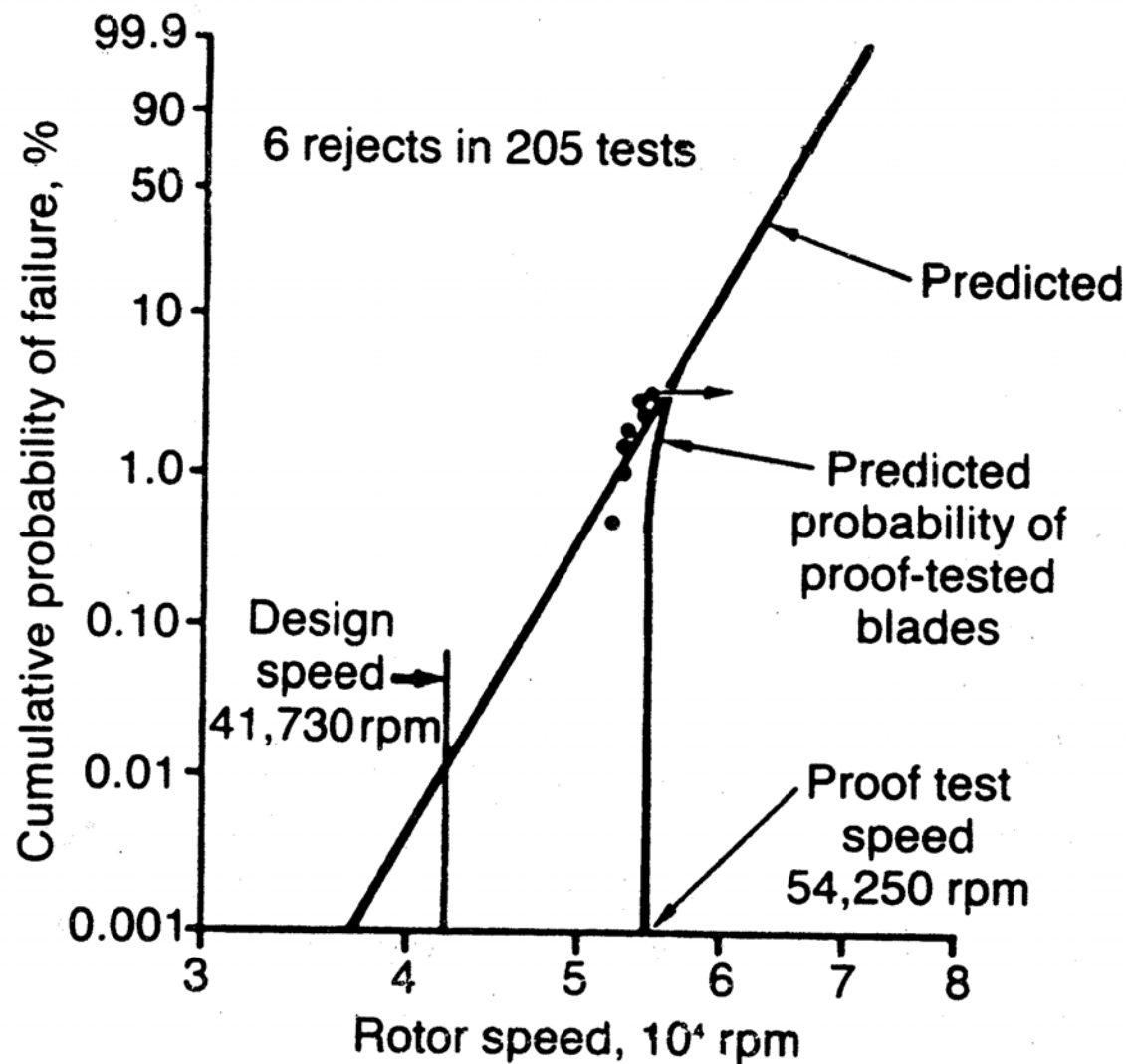


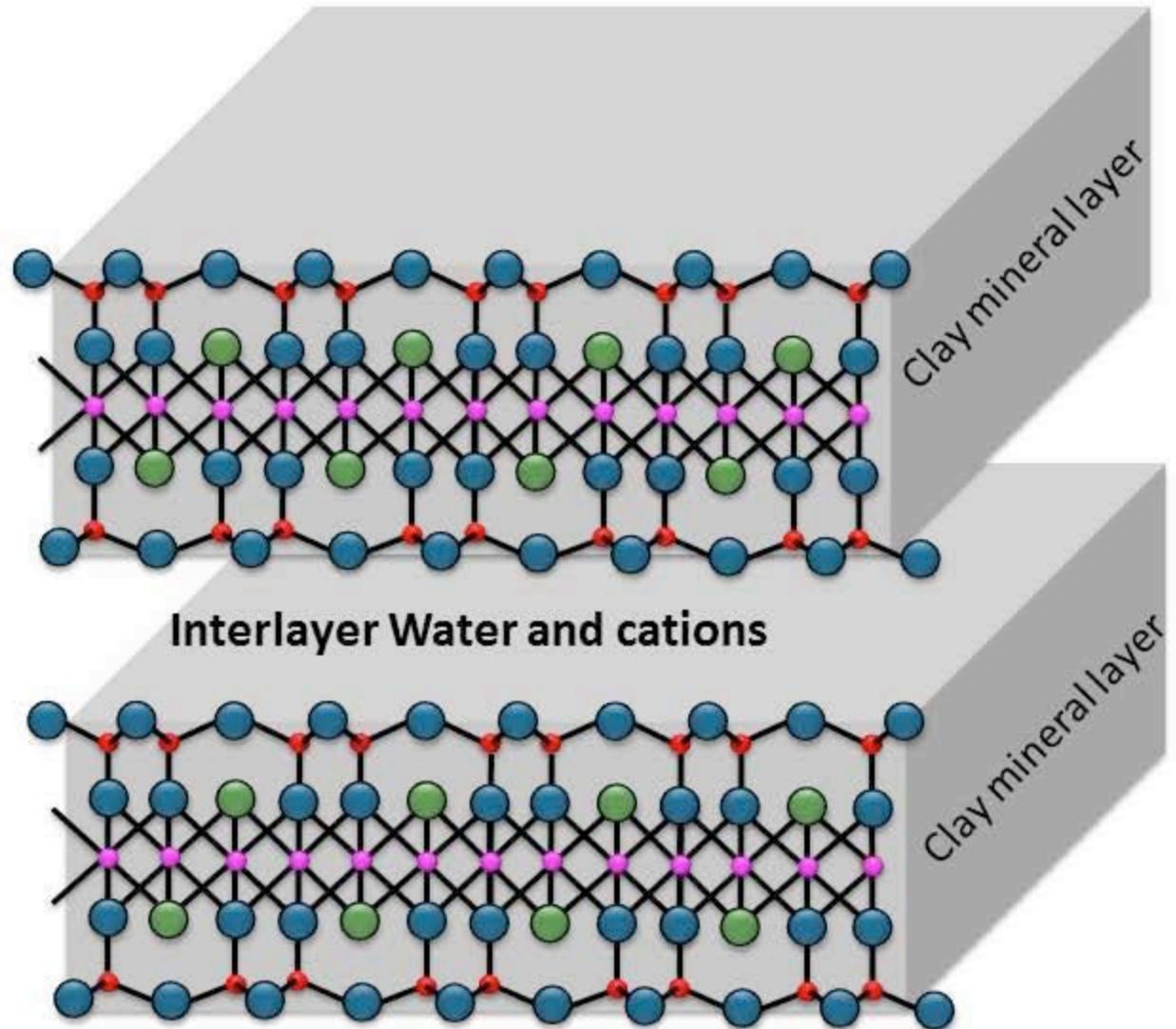
Figure 15.12 Rotor blade spin proof-test results that show good correlation between predicted and actual probability of failure for hot-pressed Si_3N_4 rotor blades. (From D. W. Richerson, Design with ceramics for heat engines, paper presented at U.S./Japan Seminar on Structural Ceramics, Seattle, Wash., Aug. 13–15, 1984.)

Raw materials for traditional ceramics

- Halloysite $\text{Al}_2\text{Si}_2\text{O}_5(\text{OH})_4 \cdot 2\text{H}_2\text{O}$
- Montmorillonite
 $(\text{Na}, \text{Ca})_{0,3}(\text{Al}, \text{Mg})_2\text{Si}_4\text{O}_{10}(\text{OH})_2 \cdot n(\text{H}_2\text{O})$
- In genere prodotto di dilavamento feldspatico:
- Feldspati $(\text{Ba}, \text{Ca}, \text{Na}, \text{K}, \text{NH}_4)(\text{Al}, \text{B}, \text{Si})_4\text{O}_8$

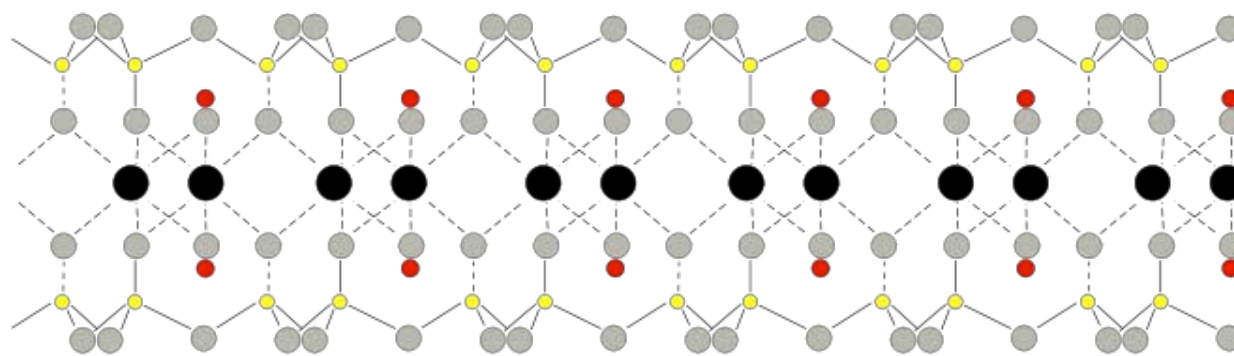
Clay Mineral Structure

- Silica, Aluminum atom
- Magnesium atom
- Oxygen atom
- Hydroxyl group



Montmorillonite

Layer spacing
ca. 1-2 nm or more



Tetrahedral

Octahedral

Tetrahedral

H₂O

H₂O

H₂O

+

+

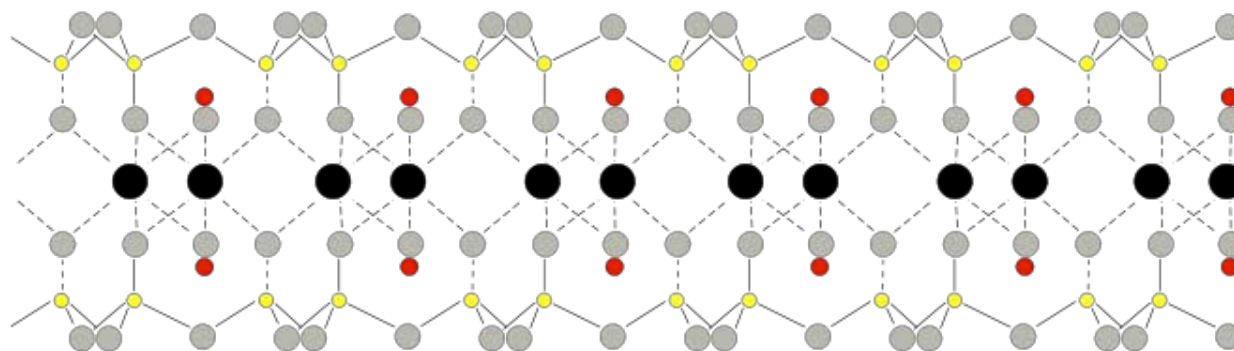
+

Water and
exchangeable
cations

H₂O

H₂O

H₂O

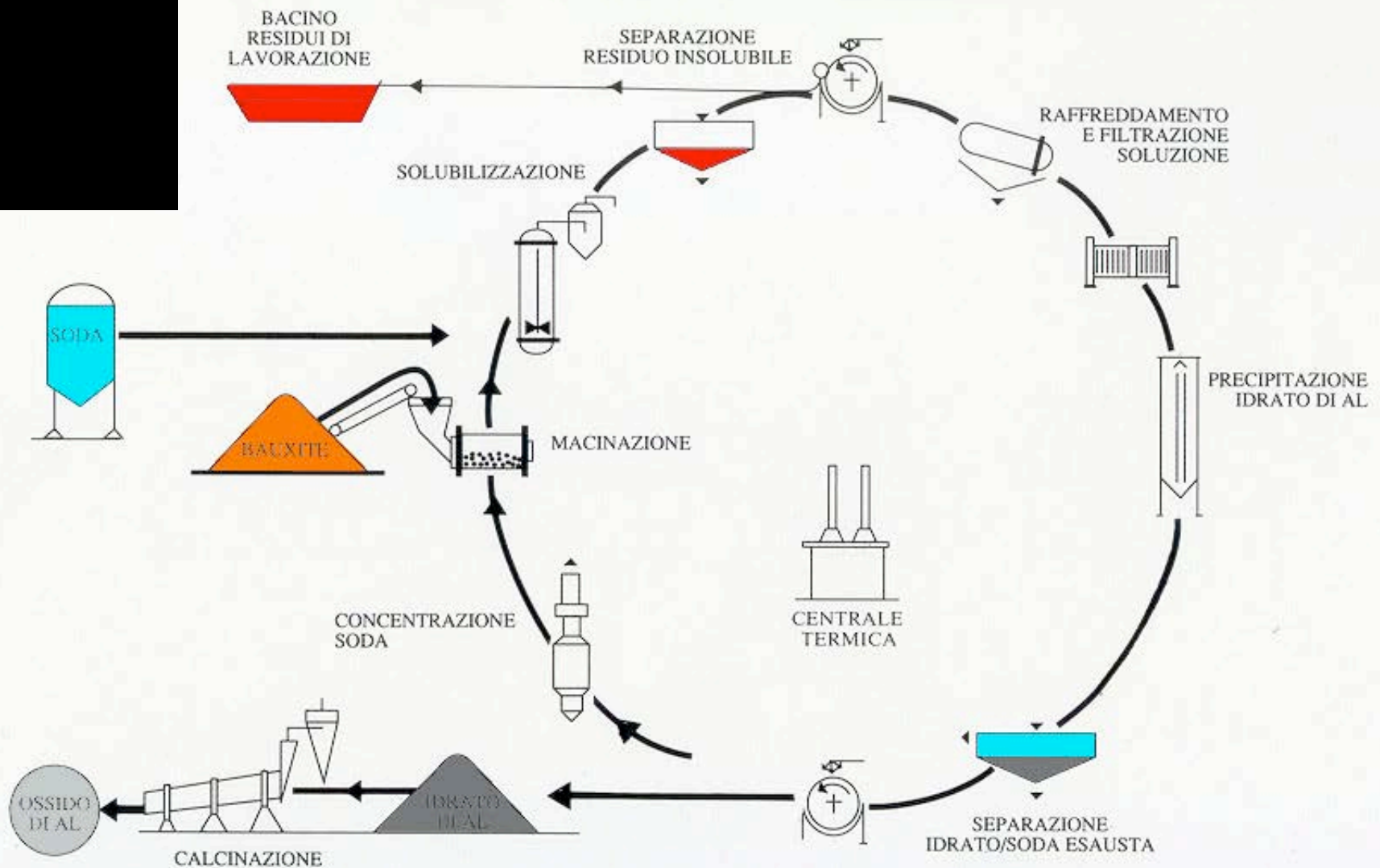


● Oxygen

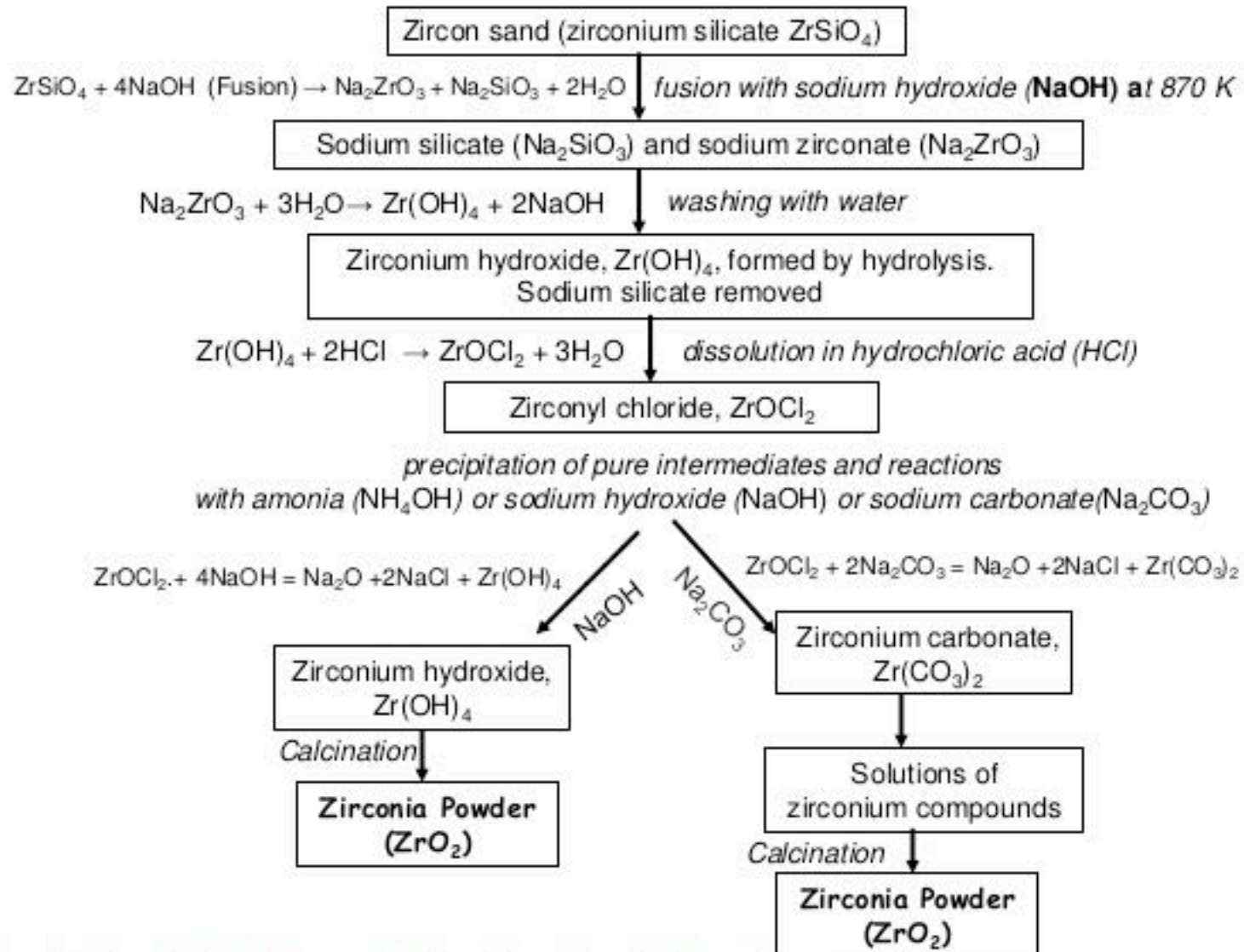
● Silicon

● Hydrogen

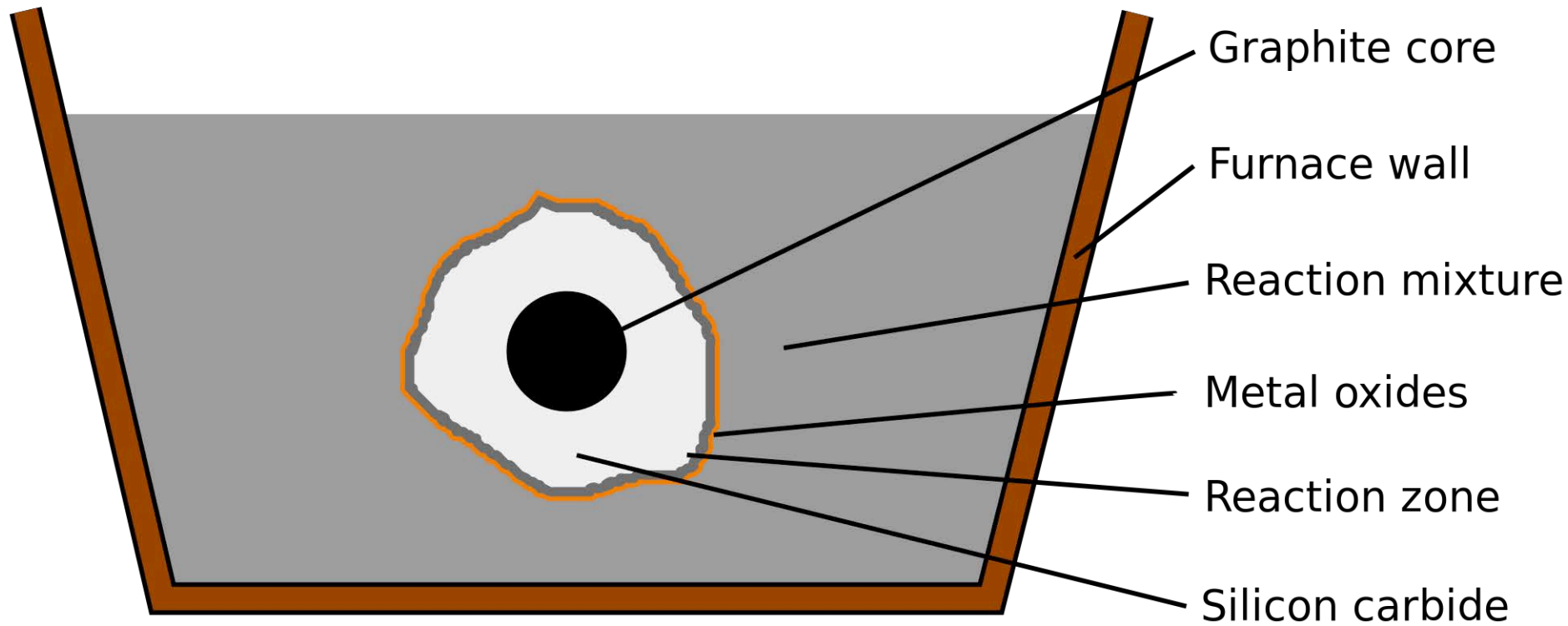
● Aluminium



Zirconia powder preparation



Acheson process: $3\text{C} + \text{SiO}_2 \Rightarrow \text{SiC} + 2\text{CO}$

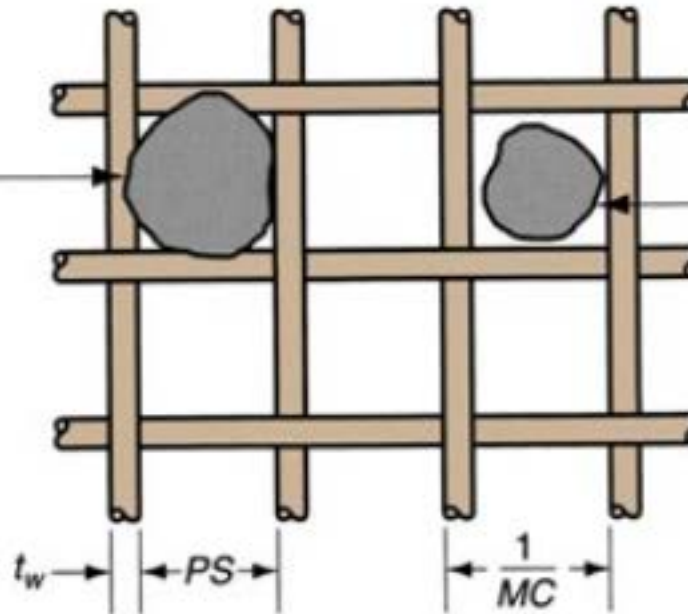




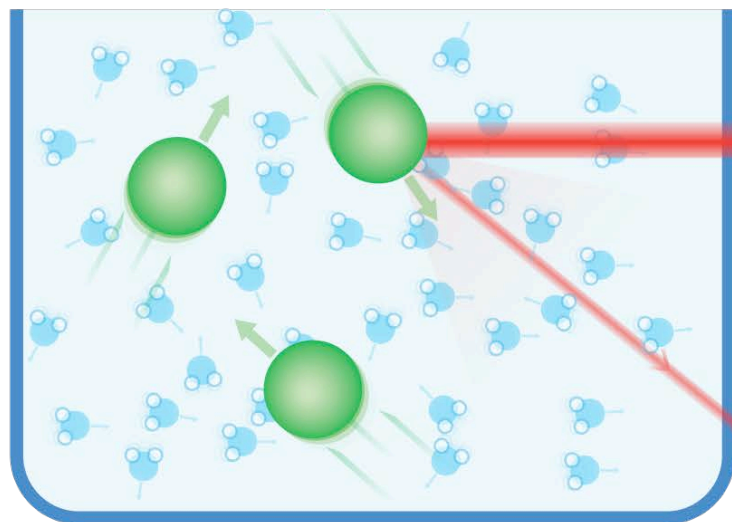
Measuring Particle Size

- Most common method uses screens of different mesh sizes
- *Mesh count* - refers to the number of openings per linear inch of screen
 - A mesh count of 200 means there are 200 openings per linear inch
 - Since the mesh is square, the count is equal in both directions, and the total number of openings per square inch is $200^2 = 40,000$
 - *Higher mesh count = smaller particle size*

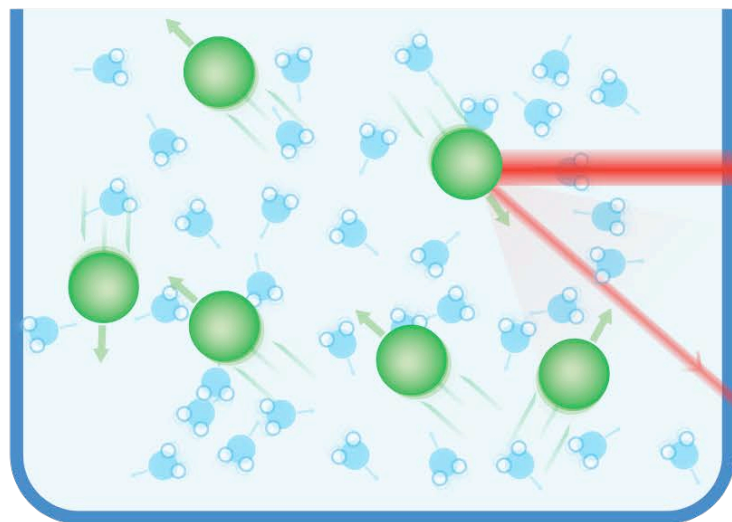
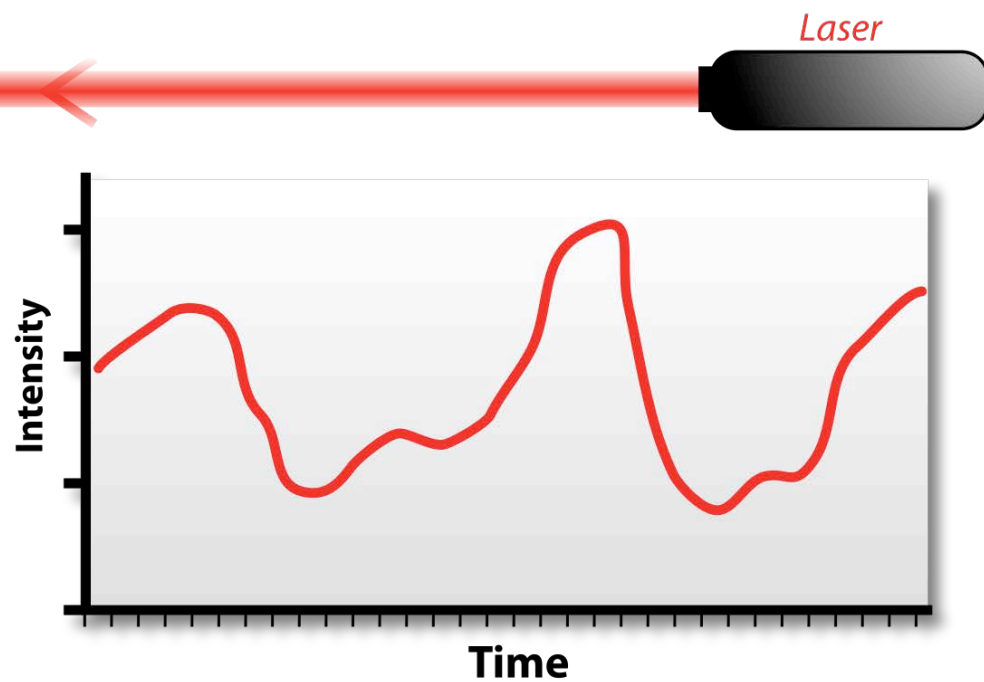
Particle size that would not pass through mesh



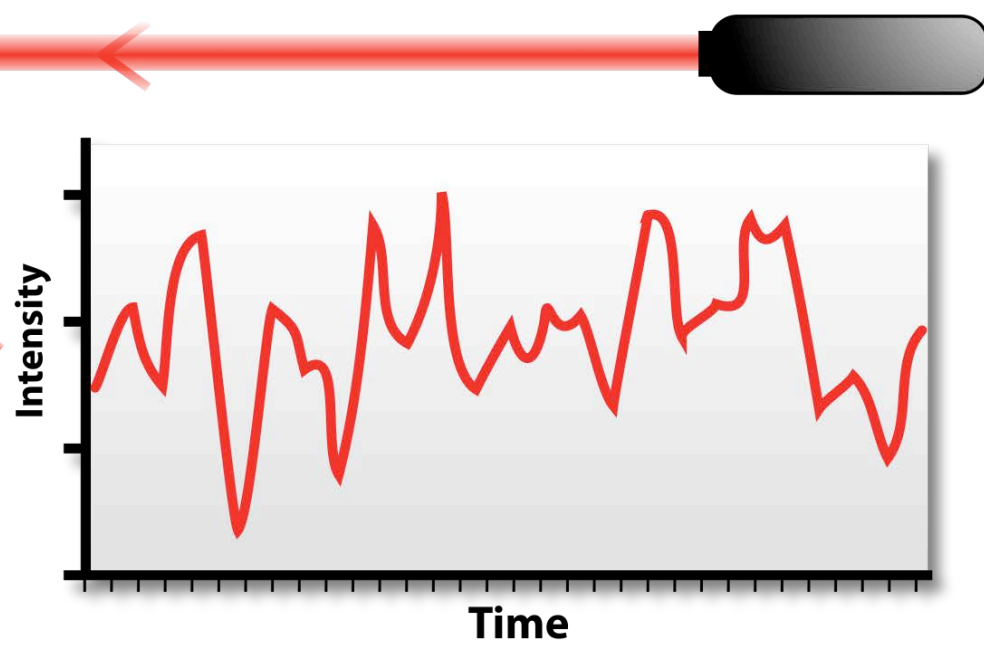
Particle size that would pass through mesh



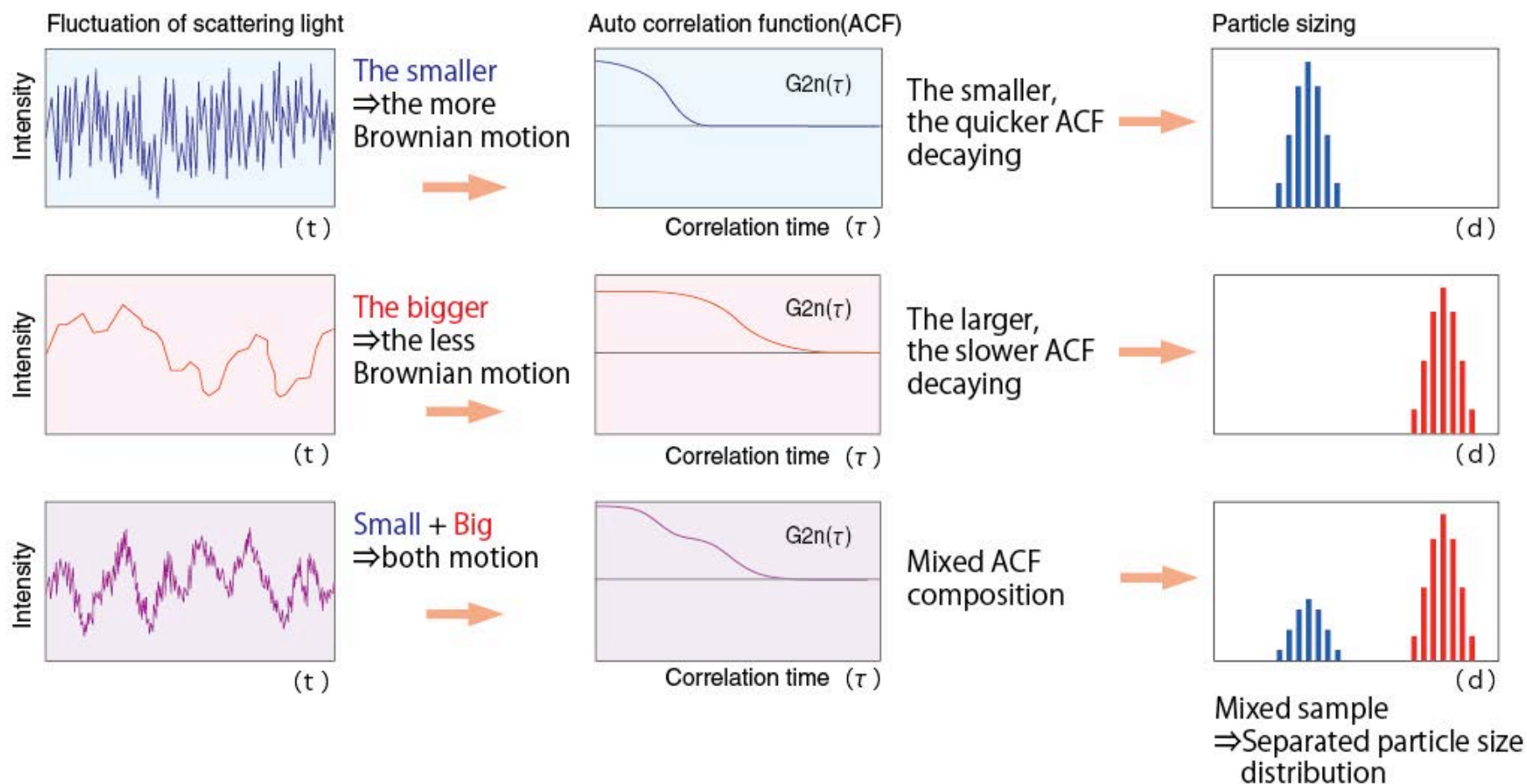
Larger Particles



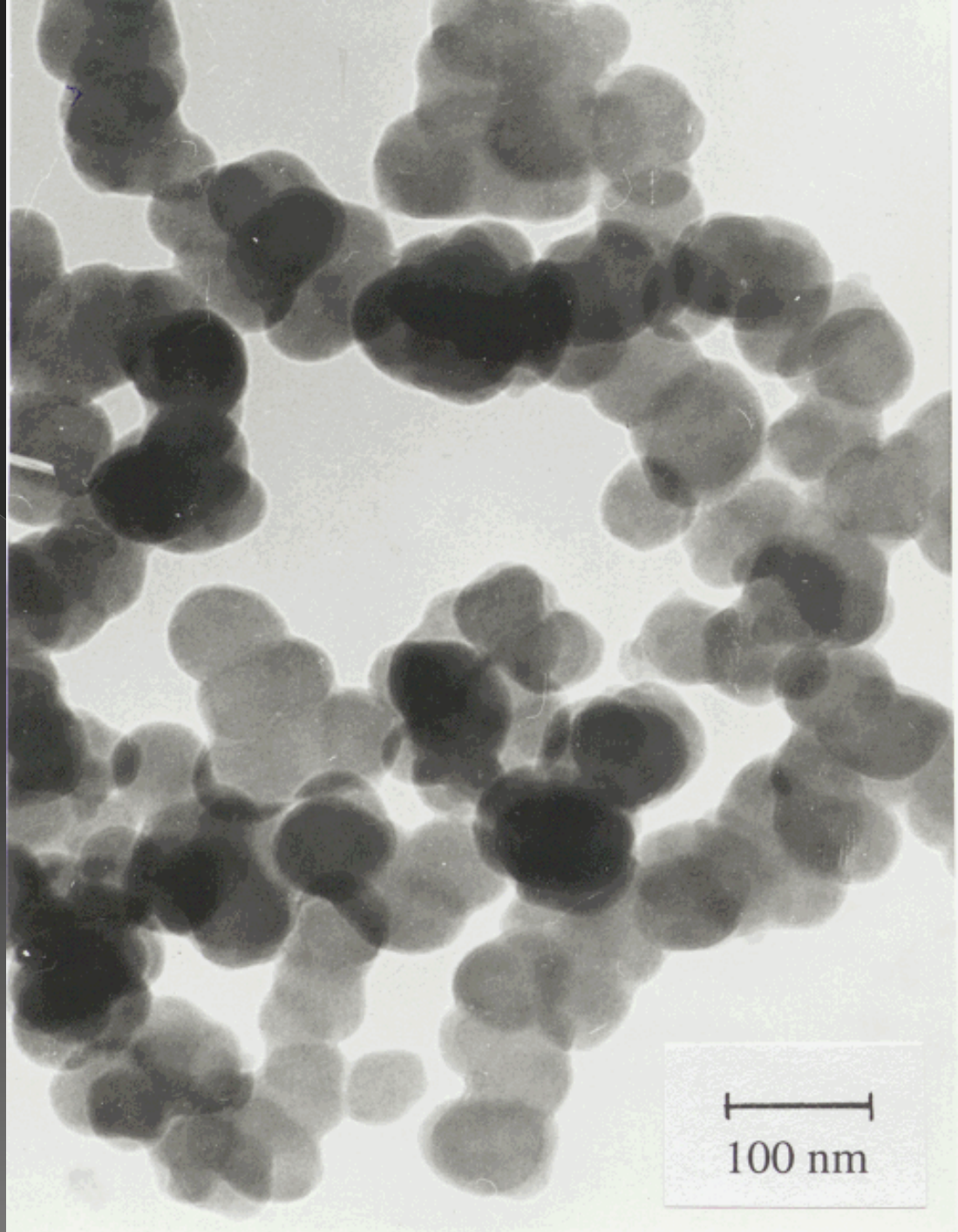
Smaller Particles

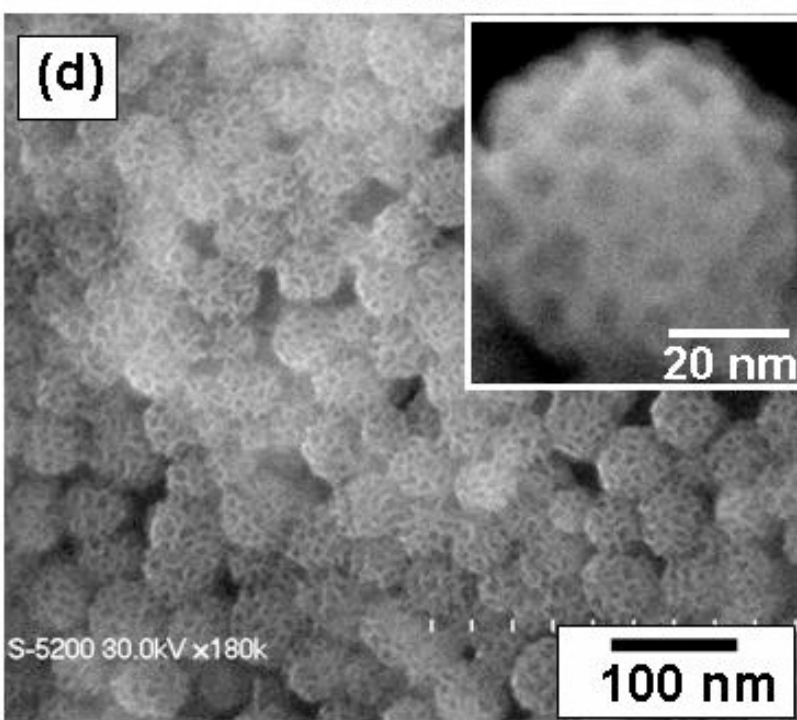
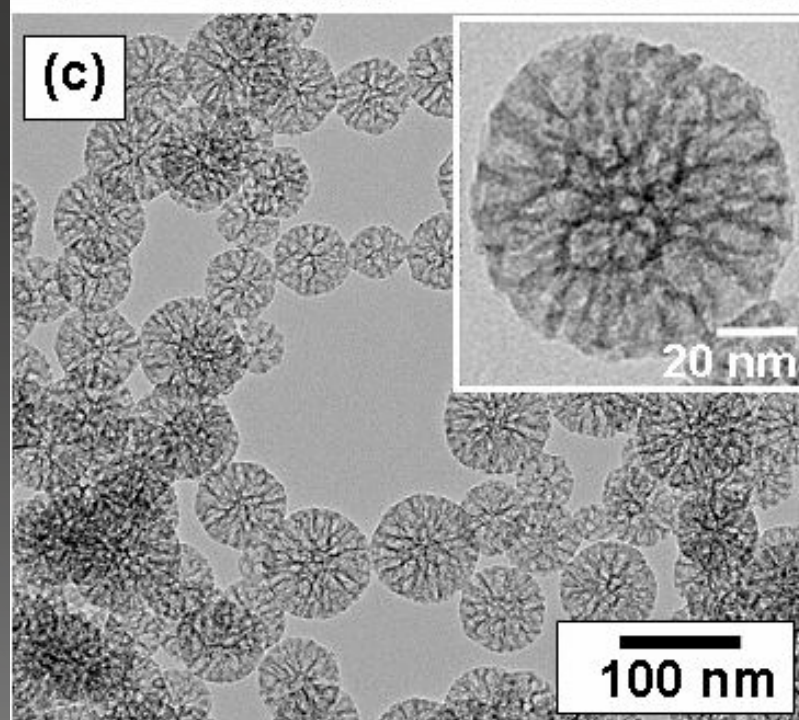
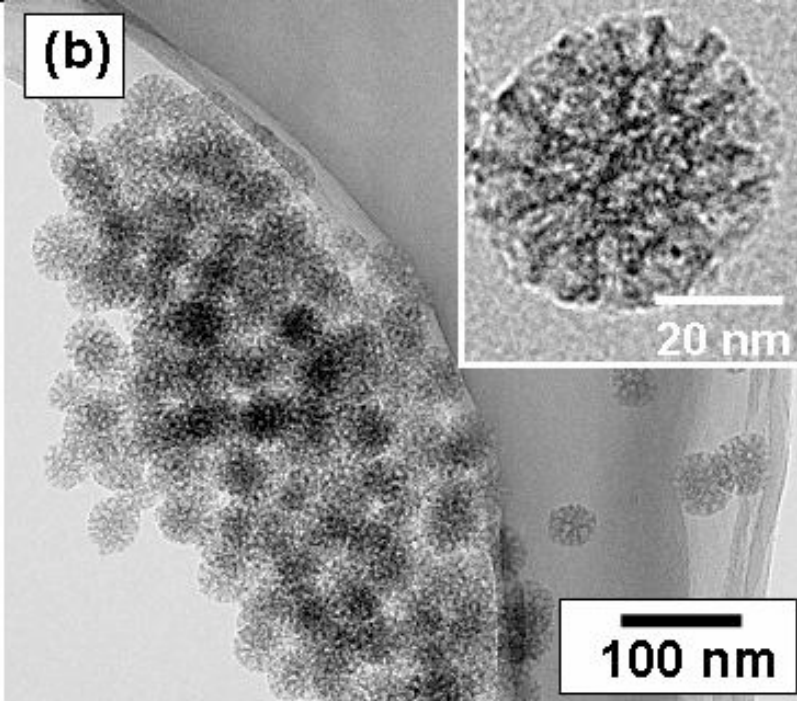
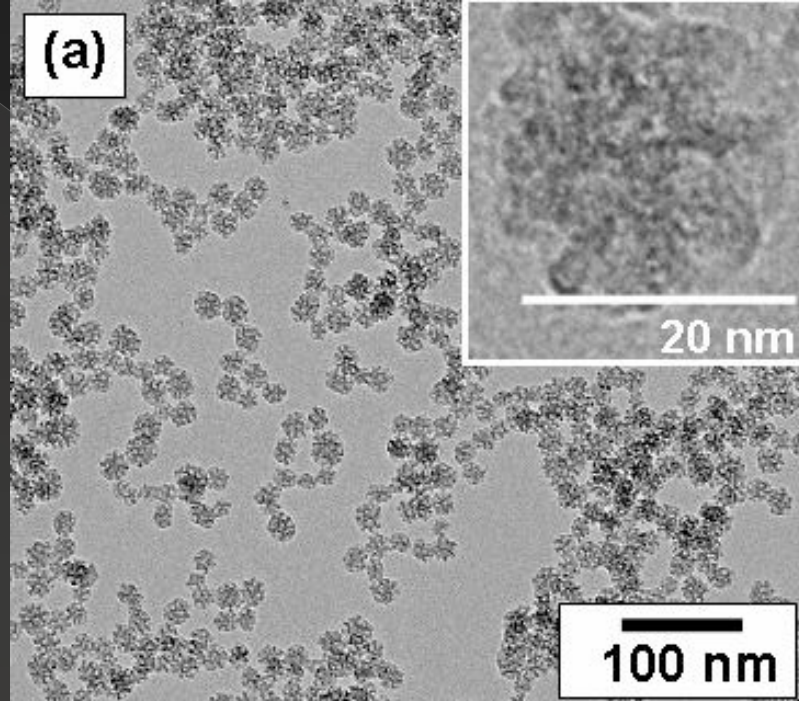


Dynamic light scattering

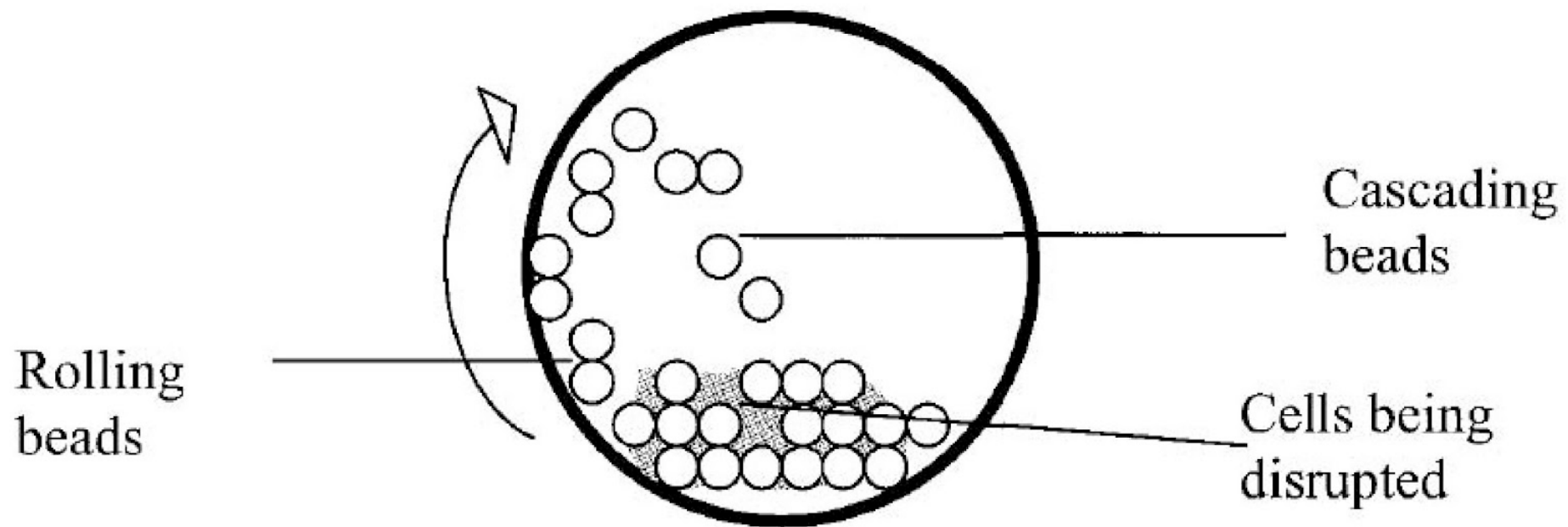


Si_3N_4

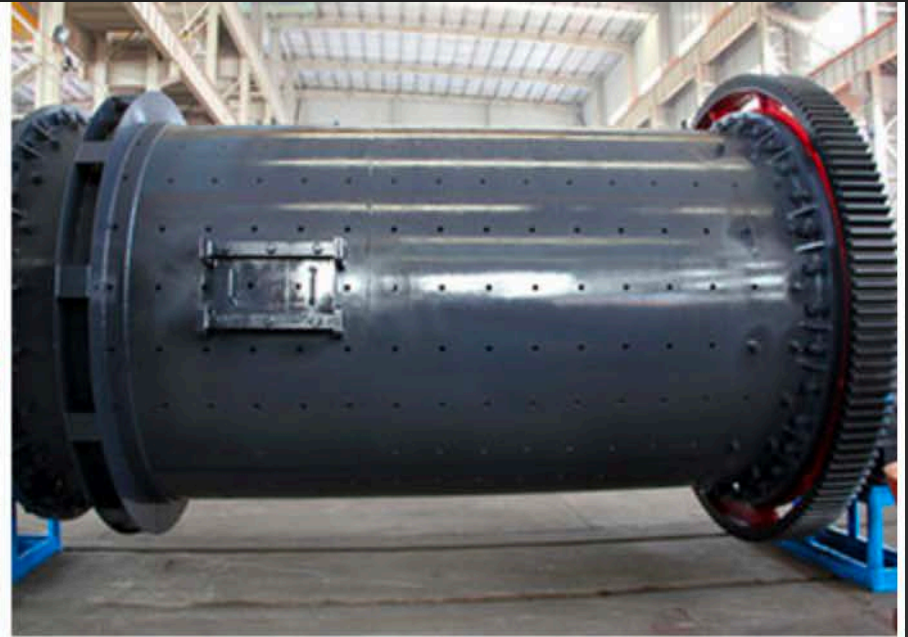




Ball milling



Industrial ball mills



Attrition milling

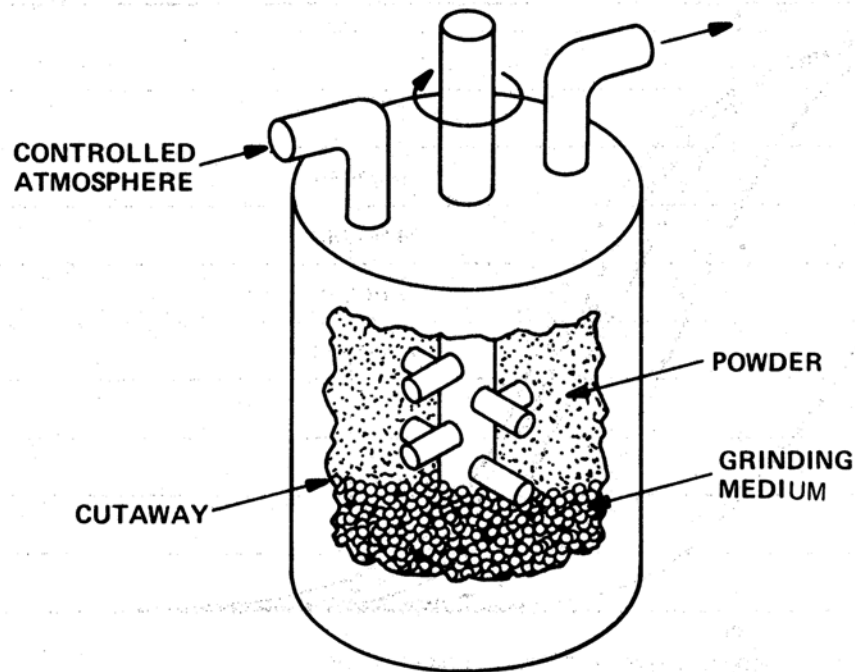


Figure 9.7 Schematic of an attrition mill. (Adapted from T. P. Herbell and T. K. Glasgow, NASA, paper presented at the DOE Highway Vehicle Systems Contractors Coordination Meeting, Dearborn, Mich., Oct. 17–20, 1978.)

Industrial attrition mills

CENTRIFUGAL IMPACT MILLS



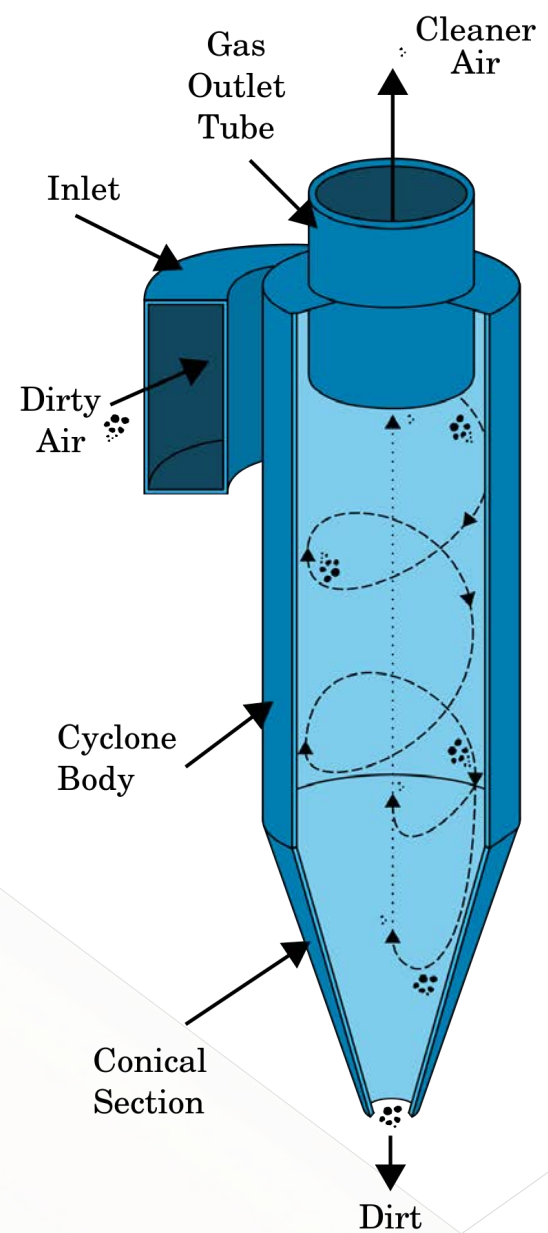
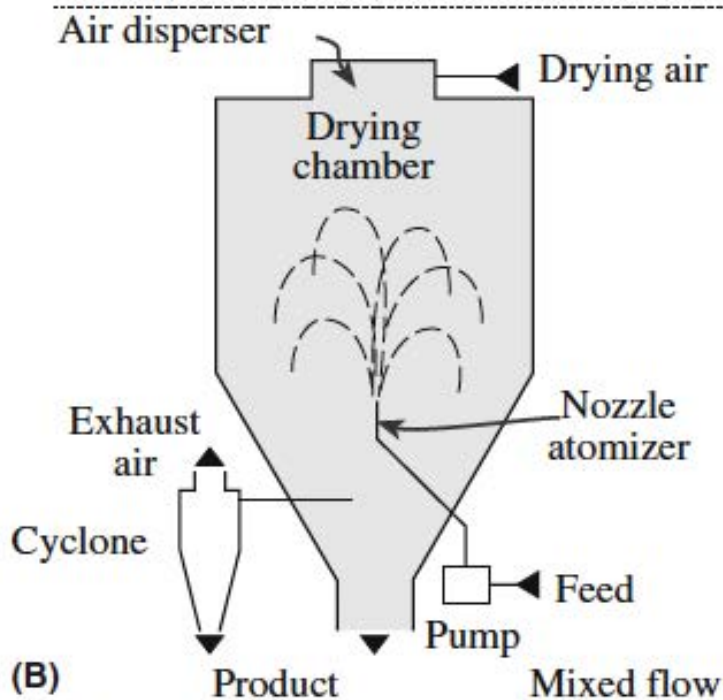
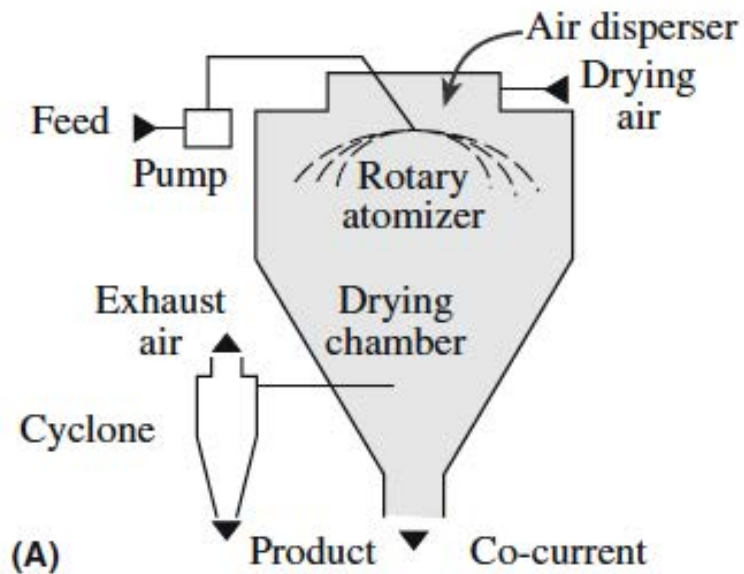
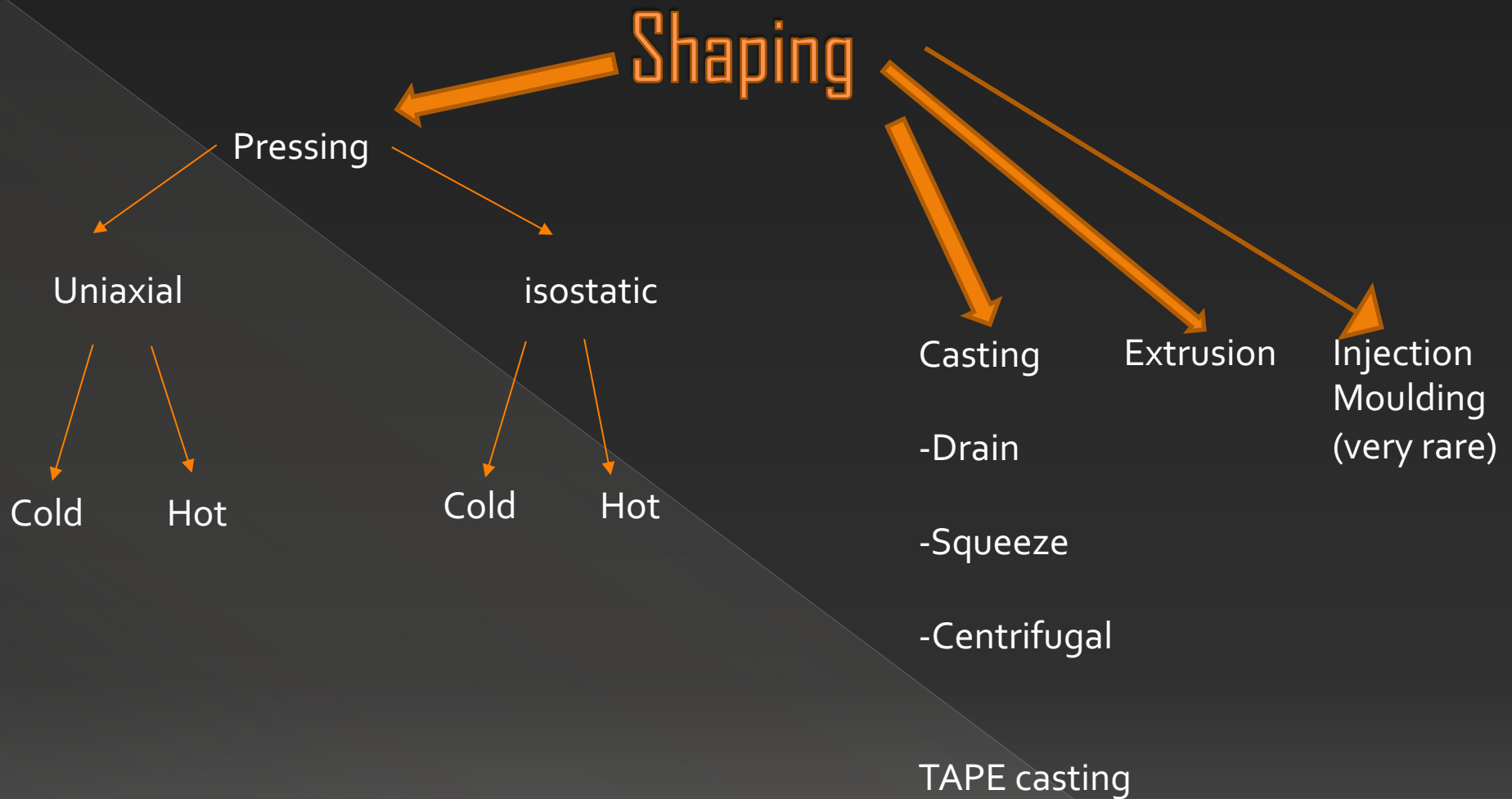


FIGURE 20.3 Spray dryers: (a) Centrifugal atomizer with cocurrent air flow. (b) Nozzle atomizer using mixed-flow conditions.



Overall process from starting powder to slurry:
<https://www.youtube.com/watch?v=UHD1SzAJjU8>

Slurry preparation (impasto/barbottina)

- Ceramic powder 50%
- Water (or other suspension media) 40%
- Binder (legante) 5%
 - > Organic: PVA, PEG, Cellulose, starch
 - > Inorganic: Clay, colloidal silica, aluminates
- Plasticizer (plasticizzante) 2-3%
- Lubricant (lubrificante) 1-2%
 - > Stearic acid or stearata
 - > Graphite, BN, steatite

Typical composition of slurry

Components	Amounts (%)
PZT powder	65–70
Dispersant	1.25
Solvent	25
Plasticizer	1.75
Binder	2

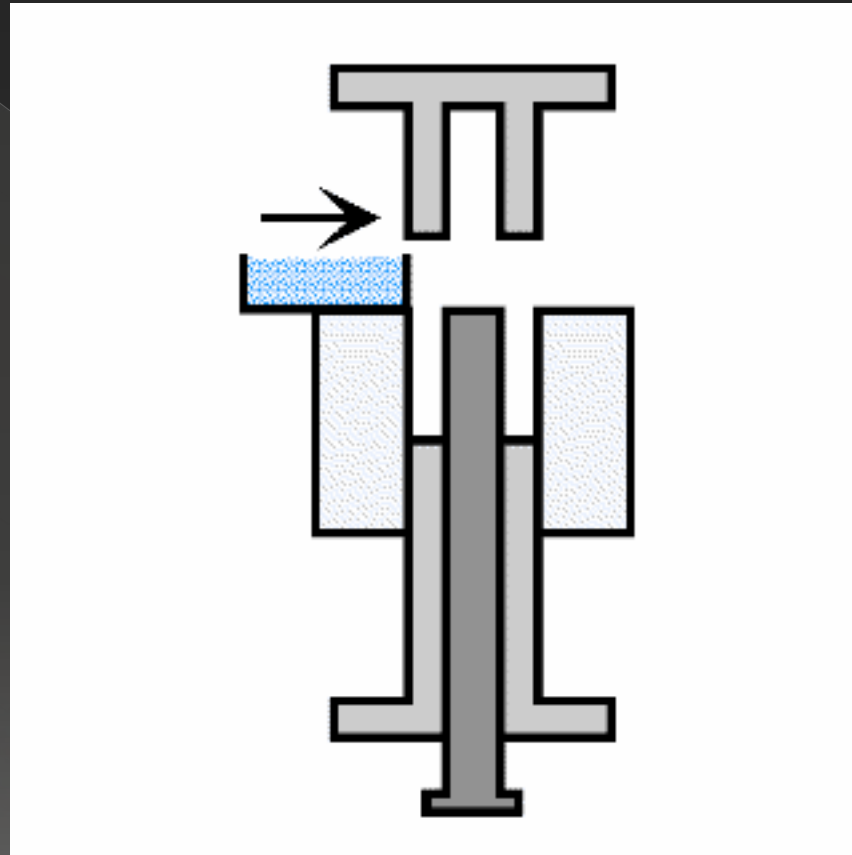
TABLE 23.3 Examples of Compositions of Extruded Bodies (Composition in vol%)

<i>Refractory alumina</i>		<i>High alumina</i>		<i>Electrical porcelain</i>	
Alumina (<20 μm)	50	Alumina (<20 μm)	46	Quartz (<44 μm)	16
Hydroxyethyl cellulose	6	Ball clay	4	Feldspar (<44 μm)	16
Water	44	Methylcellulose	2	Kaolin	16
AlCl ₃ (pH > 8.5)	<1	Water	48	Ball clay	16
		MgCl ₂	<1	Water	36
				CaCl ₂	<1

TABLE 23.4 Additives for Injection Molding of SiC

<i>Function</i>	<i>Example</i>	<i>Quantity (wt%)</i>	<i>Volatilization temperature</i>
Thermoplastic resin	Ethyl cellulose Polyethylene Polyethylene glycol	9–17	200–400°C
Wax or high-temperature volatilizing oil	Paraffin Mineral oils Vegetable oils	2–3.5	150–190°C
Low-temperature volatilizing hydrocarbon or oil	Animal oils Vegetable oils Mineral oils	4.5–8.5	50–150°C
Lubricant or mold release	Fatty acids Fatty alcohols Fatty esters	1–3	
Thermosetting resin	Epoxy Polyphenylene Phenol formaldehyde		Gives carbon 450–1000°C

Uniaxial pressing



https://www.youtube.com/watch?v=WuxRkt_ics0

Cold Isostatic Pressing

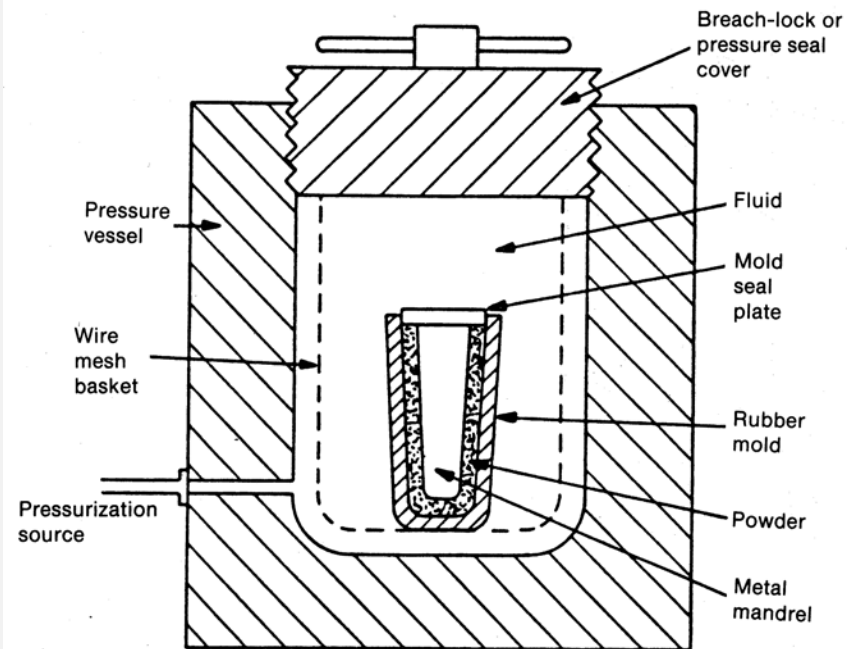


Figure 10.18 Schematic of a wet-bag isostatic pressing system. (© ASM International.)

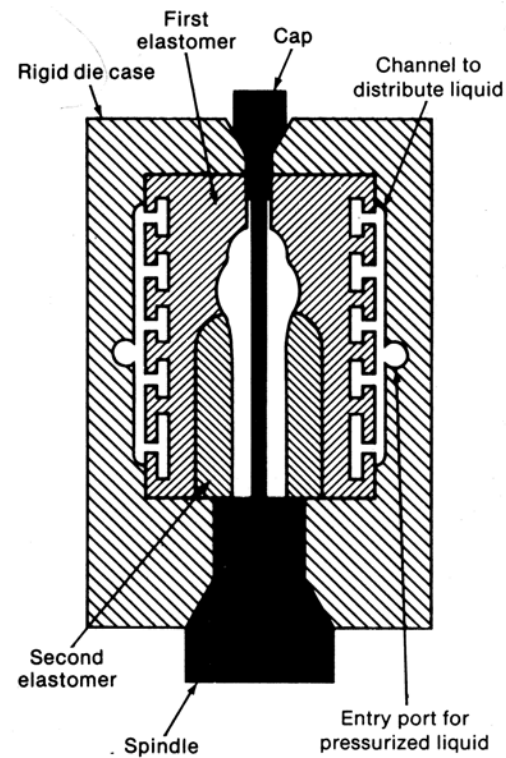
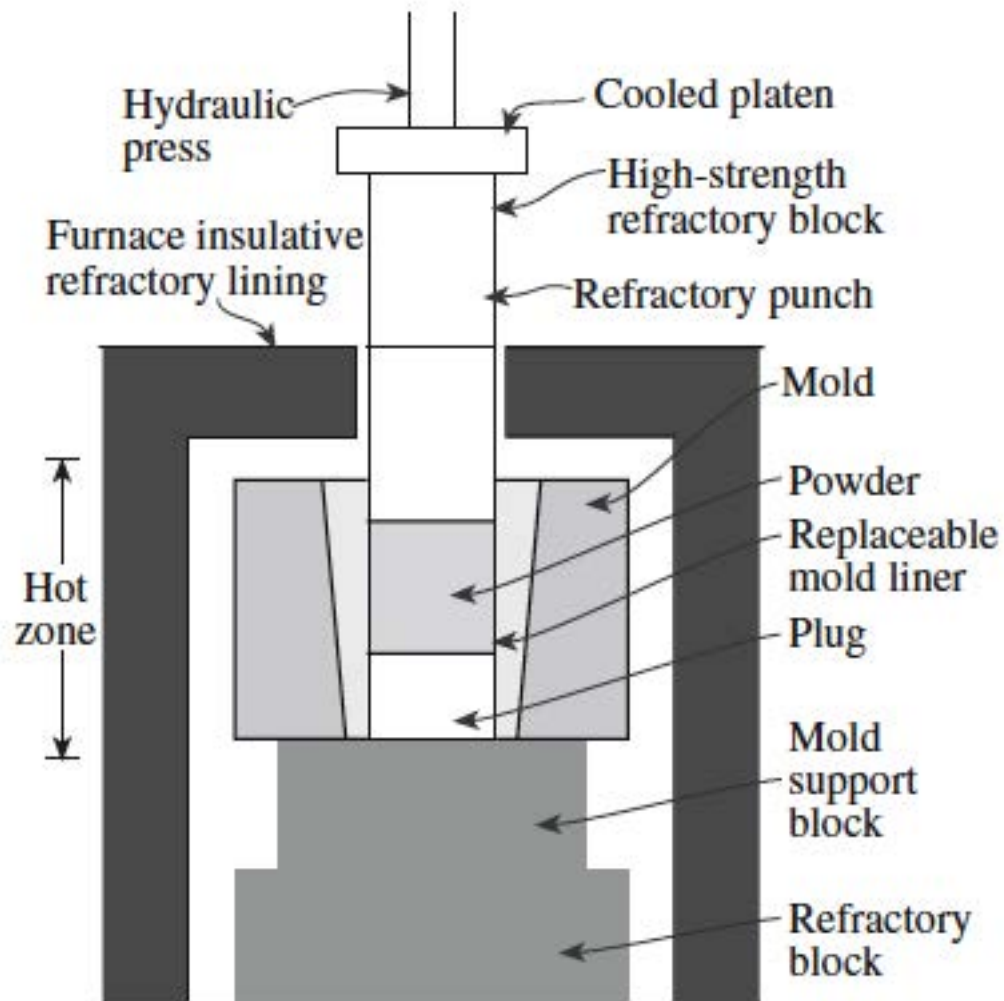
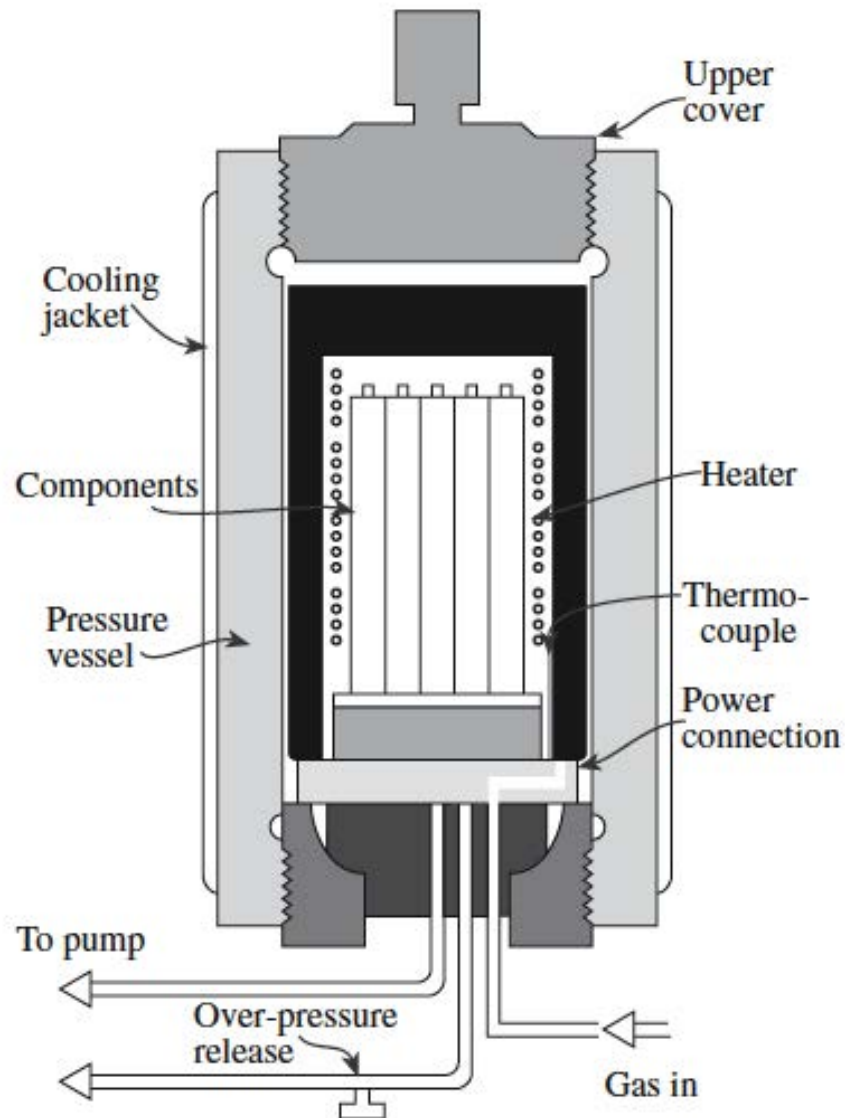


Figure 10.19 Schematic of a die for dry-bag isostatic pressing of a spark plug insulator. (© ASM International.)

Uniaxial hot press



Isostatic Hot press



Drain Casting

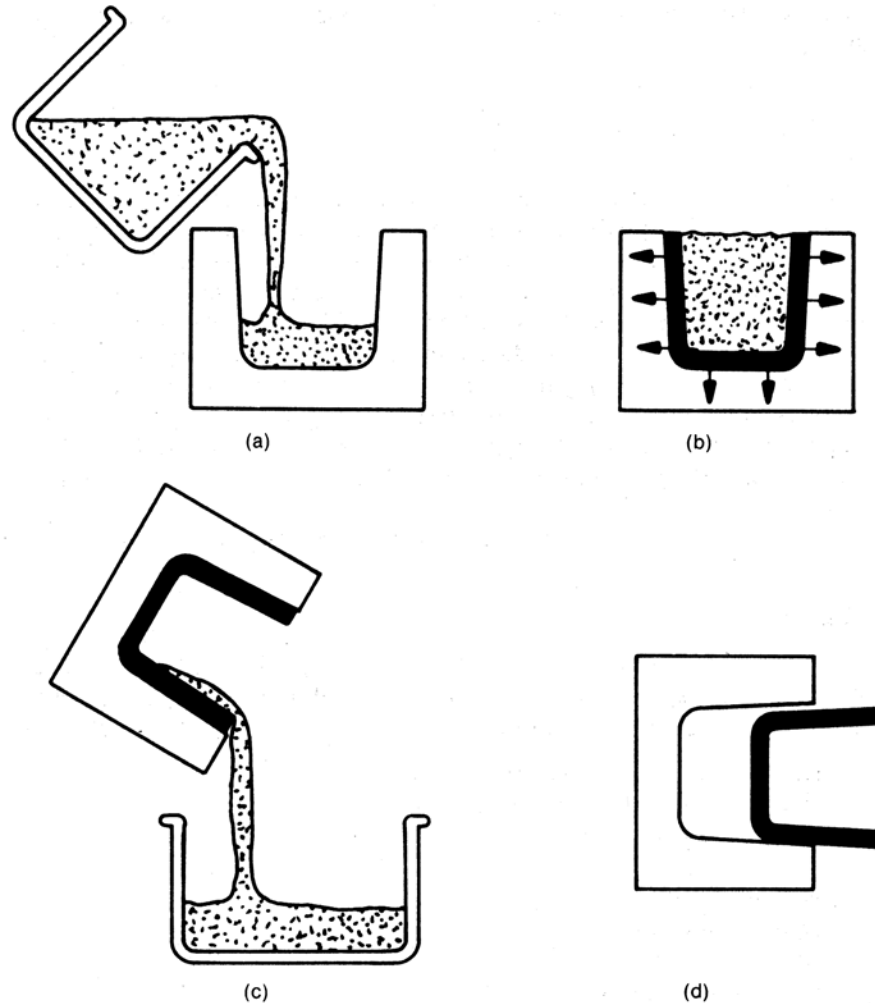
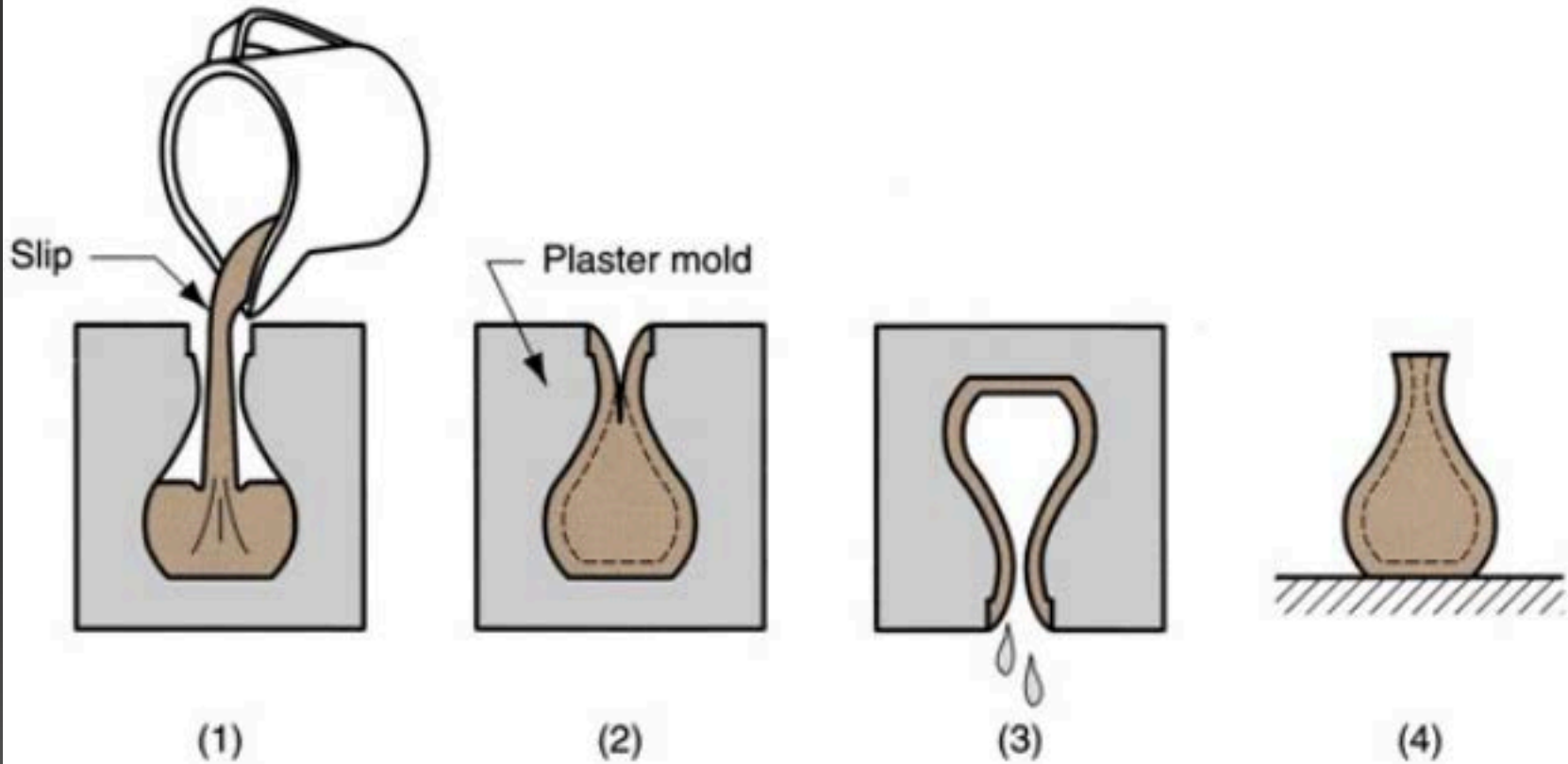


Figure 10.34 Schematic illustrating the drain-casting process. (a) Fill mold with slip, (b) mold extracts liquid, forms compact along mold walls, (c) excess slip drained, and (d) casting removed after partial drying.

Casting



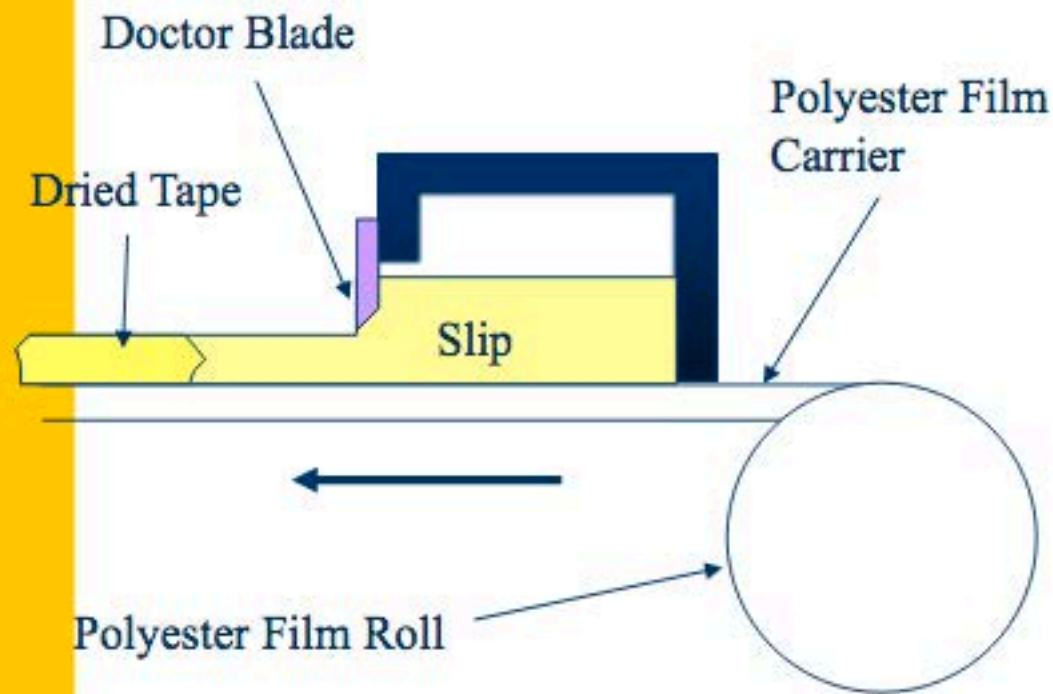
<https://www.youtube.com/watch?v=FZzOTX9lhqs>

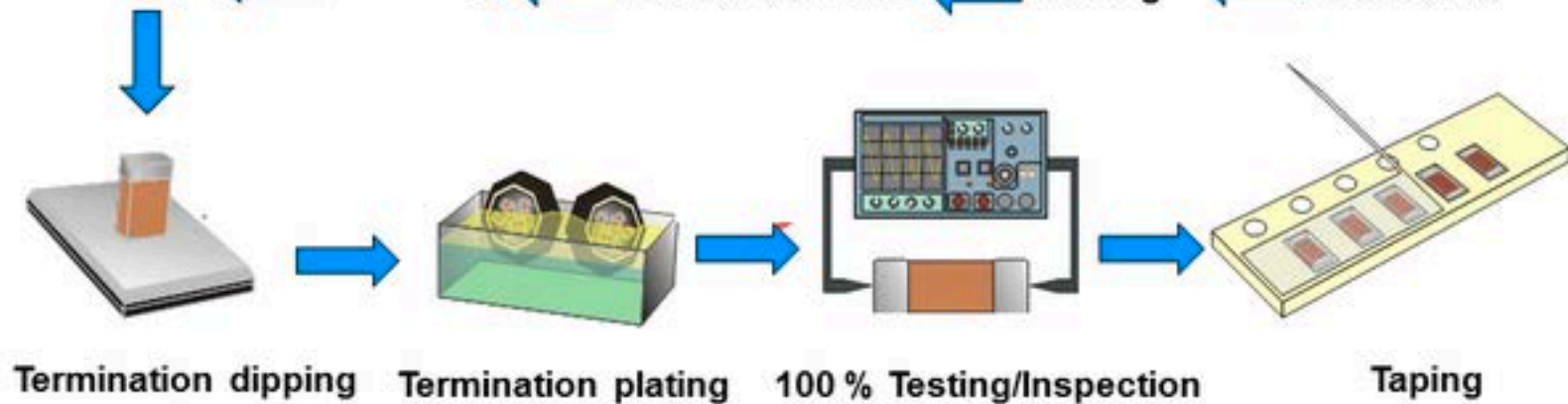
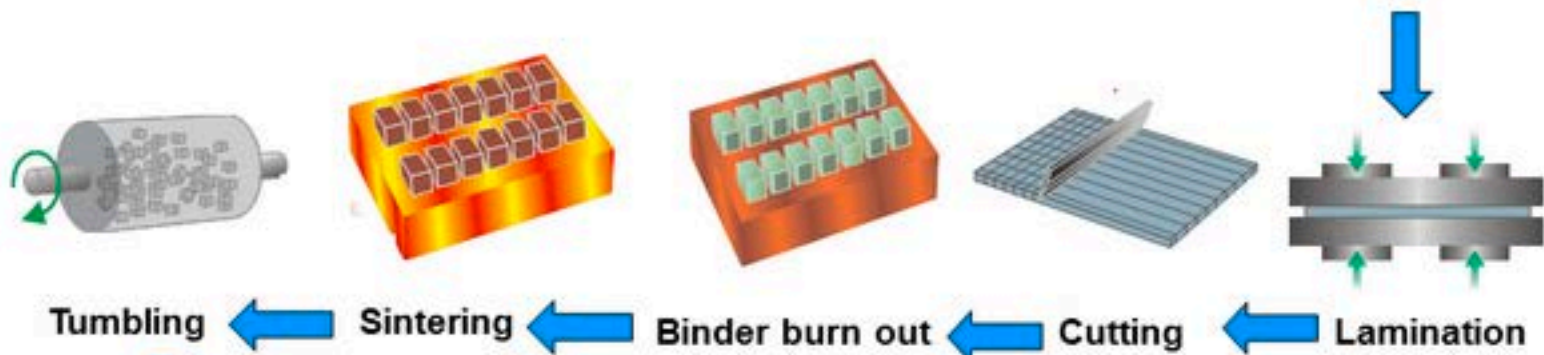
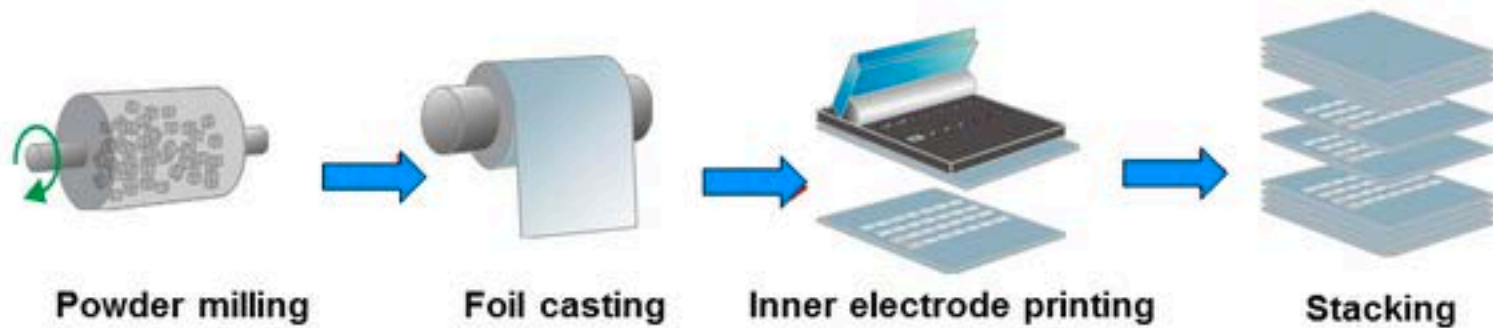
SLIP CASTING



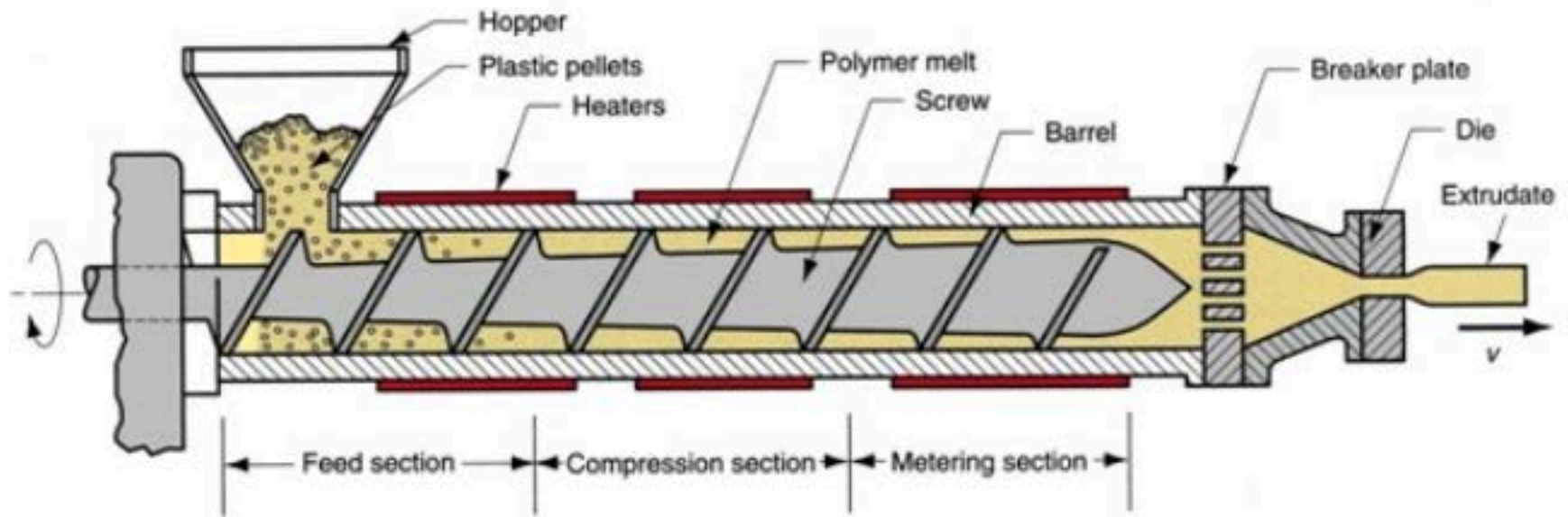
Tape Casting

Fabrication process for thin ceramic sheets





Extruder Sectional View



Components and features of a (single-screw) extruder for plastics and elastomers

TABLE 23.3 Examples of Compositions of Extruded Bodies (Composition in vol%)

<i>Refractory alumina</i>		<i>High alumina</i>		<i>Electrical porcelain</i>	
Alumina (<20 μm)	50	Alumina (<20 μm)	46	Quartz (<44 μm)	16
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Water	44	Methylcellulose	2	Kaolin	16
AlCl ₃ (pH > 8.5)	<1	Water	48	Ball clay	16
		MgCl ₂	<1	Water	36
				CaCl ₂	<1

SINTERING PROCESS

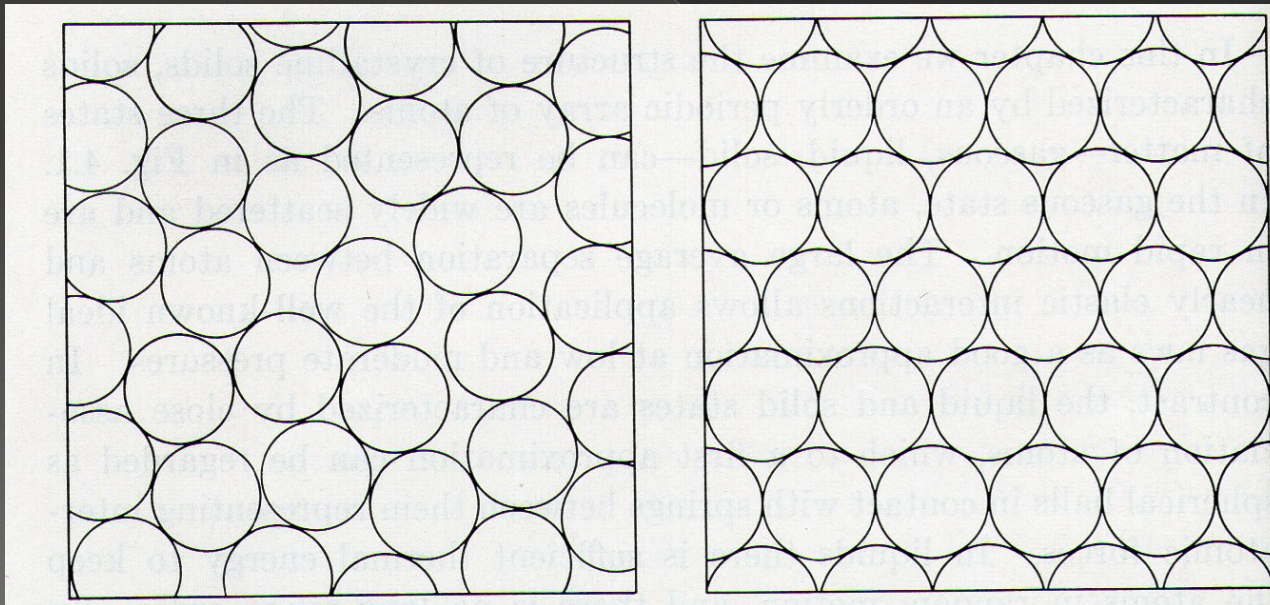
Silvia Dalla Marta

(dal corso di Scienza e tecnologia dei materiali ceramici
prof. V. Sergo)

It is a thermal process of microstructural rearrangement in which the particles of powder are compacted and the porosity decreases to form a dense piece of ceramic.

monodisperse powder fcc or hcp: $PF=74.5\%$

ceramic material with porosity:
before sintering



FORMATURE?

The absence of defects and porosity is very important for the *mechanical properties*:

$$K_{IC} = y\sigma\sqrt{c}$$

K: the parameter for the determination of the stress at the tip of the crack.

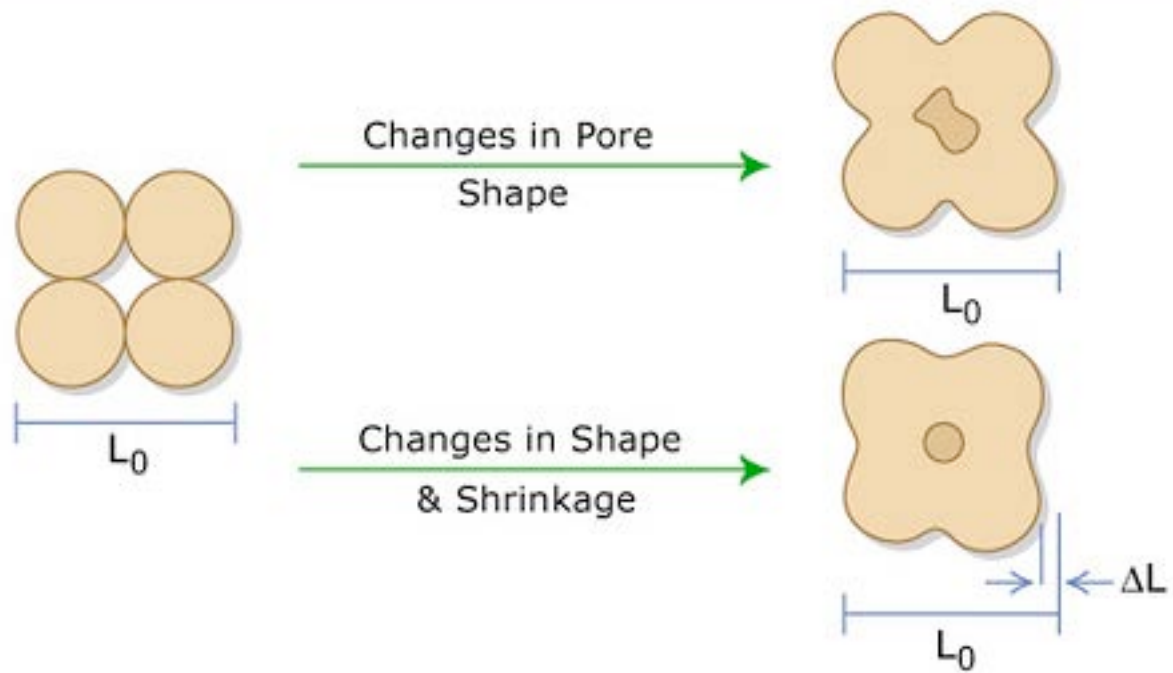
y: dimensionless constant that depends on defect's geometry and load

c: length of defect (m)

For the polycrystalline alumina: $K_{IC} = 3\text{MPa}\sqrt{\text{m}}$

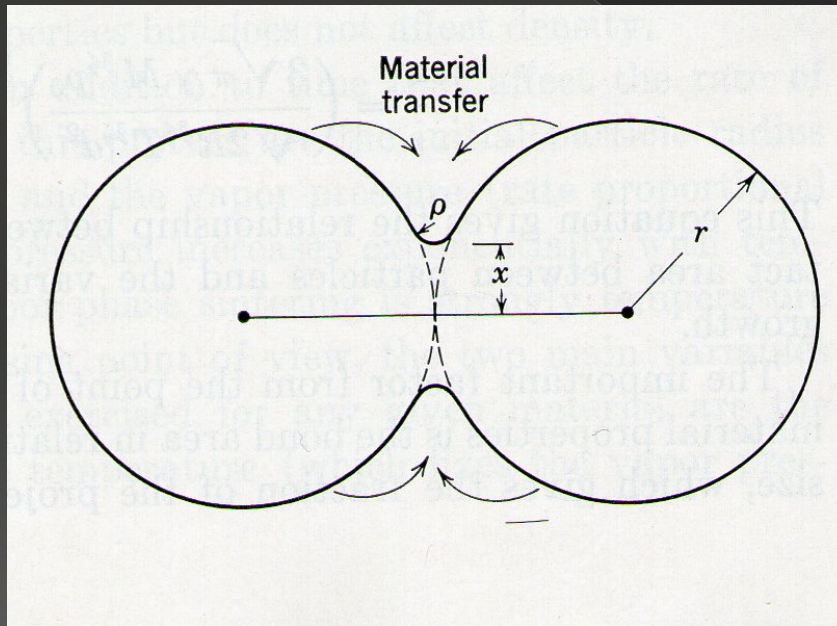
In ceramics materials these values are very low compared to metals.

A very small defect or porosity lead to failure during an application of stress.



BEFORE SINTERING:

- powder compact united by weak Van der Waals forces
- individual grains separated by 25-60% of volume porosity



Considering two particles of ceramic material in contact with each other:

- concave zone
- convex zone

The atoms in a convex zone tend to *migrate* in a concave zone in accordance with a diffusion process activated by temperature.

DIFFUSION PROCESS

- Thermodynamically favored
- kinetically slow

FICK' S LAW (1D):

$$\frac{dC}{dt} = D \frac{d^2C}{dx^2}$$

Diffusion coefficient:

$$D = D_0 e^{-\frac{E_a}{RT}}$$

In order of kinetics to be fast enough for microstructural rearrangement to occur in *short time*, the **sintering temperature** must be:

$$T = \frac{2}{3} T_m$$

SINTERING MECHANISMS

- *SURFACE DIFFUSION*
- *VAPOR TRANSPORT*



NO densification

thinning of the particles

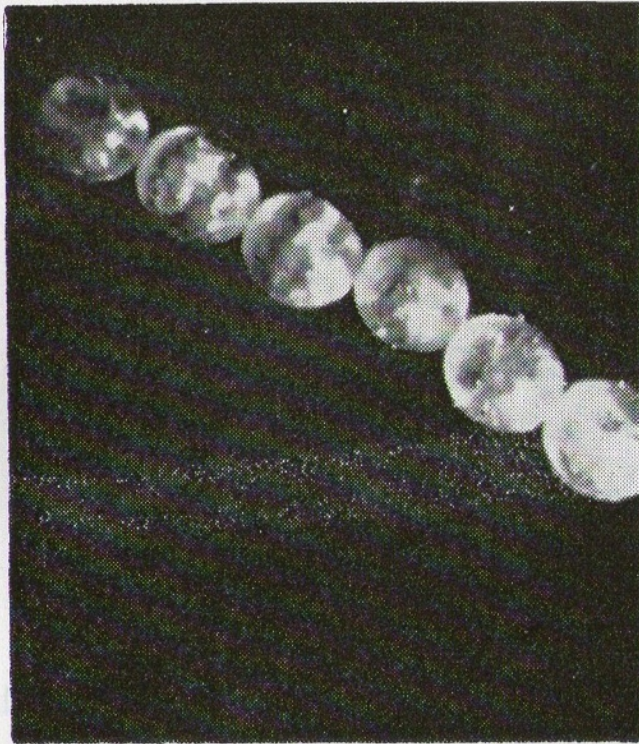
- *BULK DIFFUSION*
- *GRAIN BOUNDARY DIFFUSION*



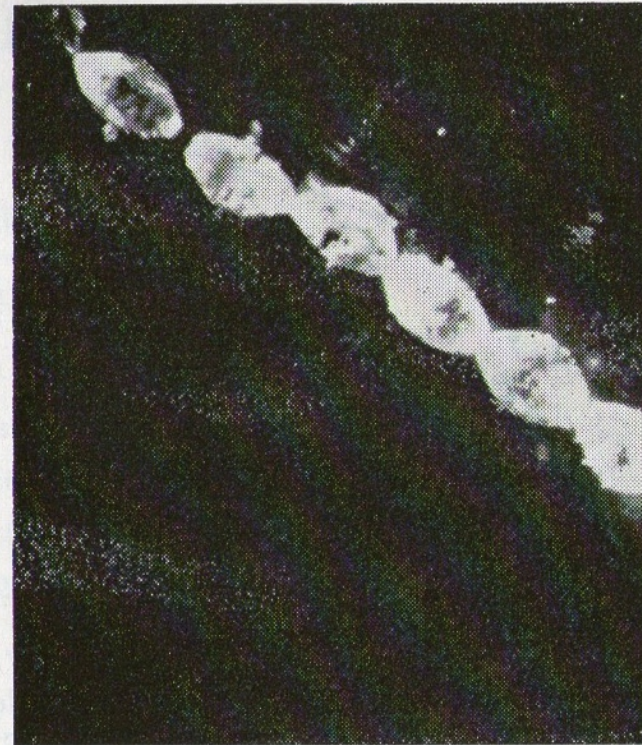
densification

decrease of the distance
between particle centres

Thinning due to vapor phase material transfer:



(a)

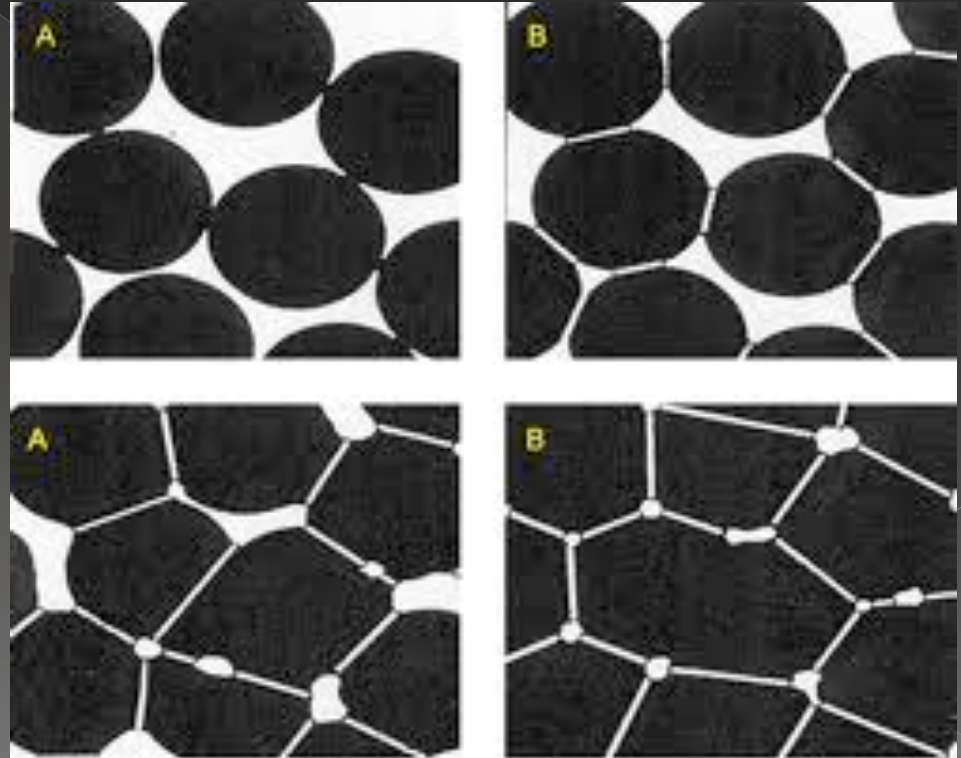


(b)

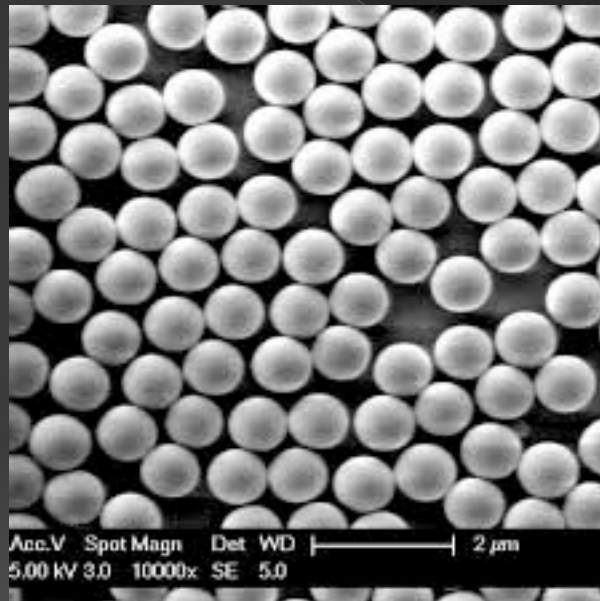
Fig. 12.17. Photomicrographs of sintering sodium chloride at 750°C : (a) 1 min, (b) 90 min.

DENSIFICATION:

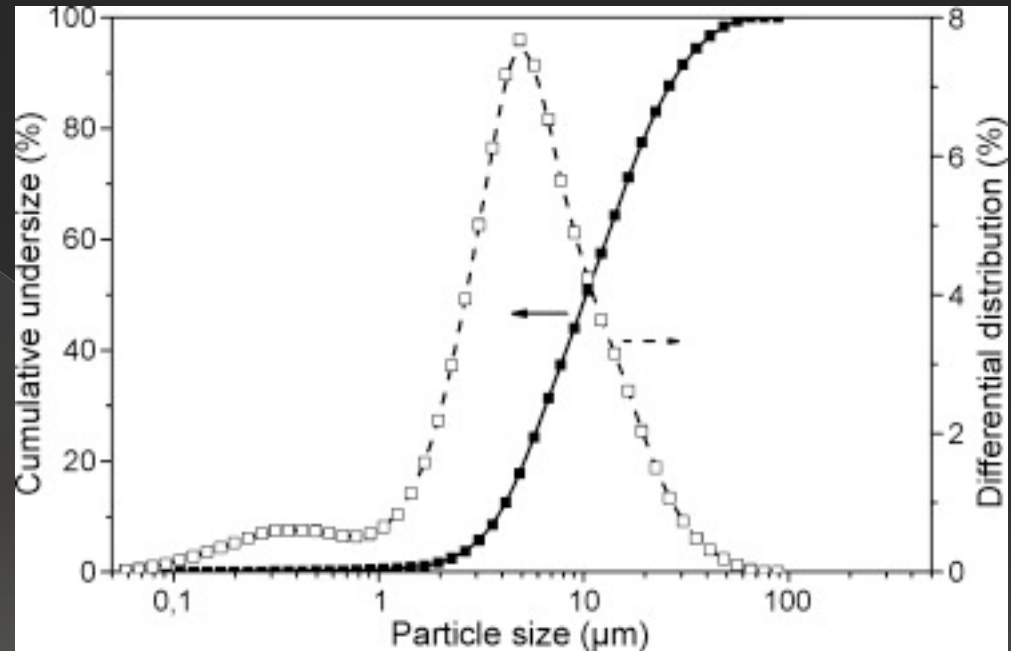
- atoms migration in the neck zone
- pores disappearance
- obtaining straight grain boundaries
- same chemical potential
- thermodynamically stable



Monodispersed powder:
rare and expensive!

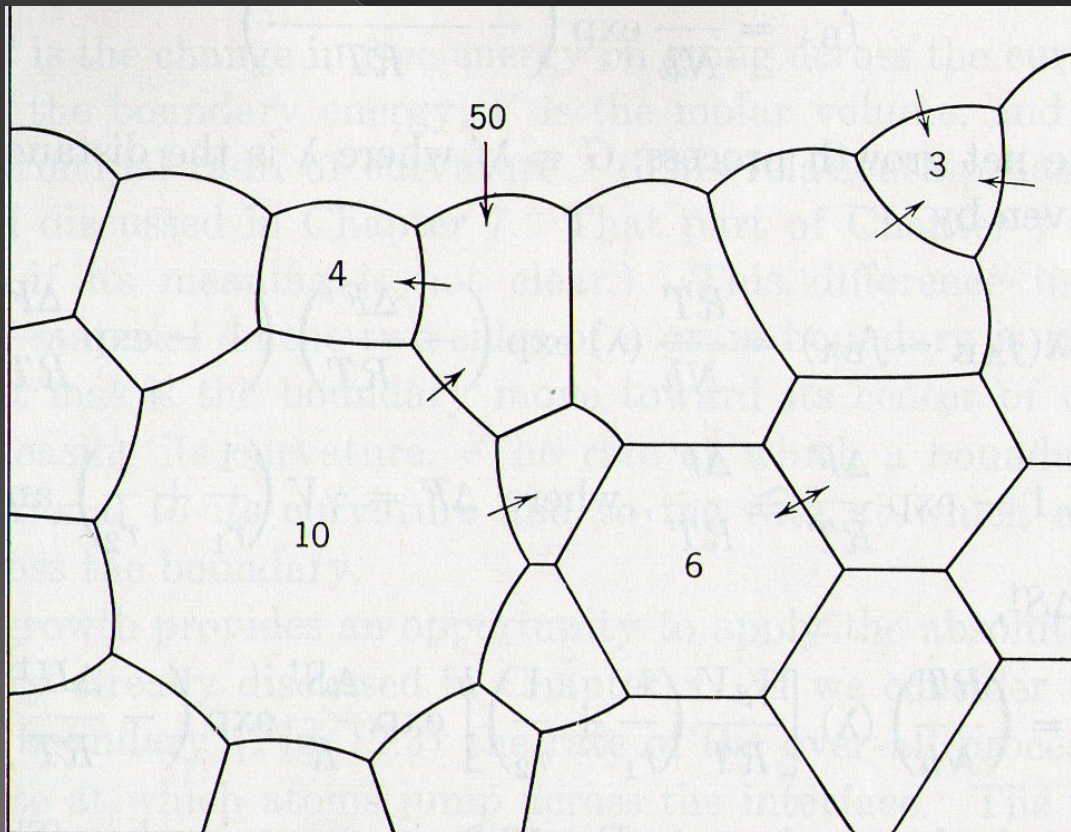


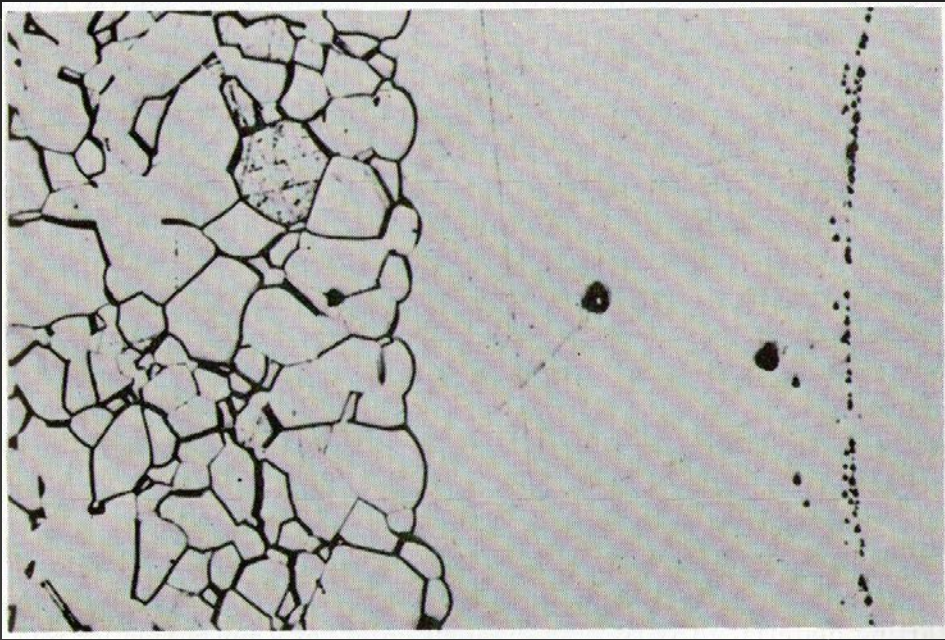
More frequent:
Grain size distribution!



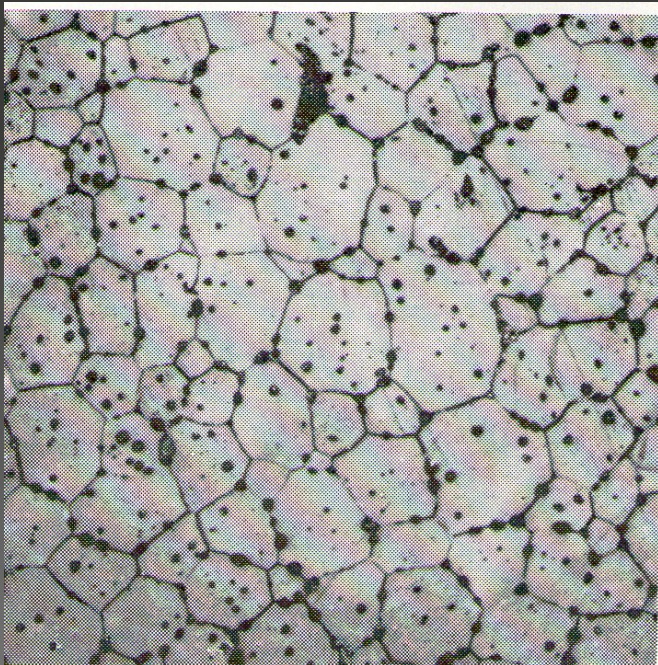
SECONDARY ABNORMAL OF BOUNDARY

Since grain boundaries migrate toward their centre of curvature, grains with more than 6 sides tend to incorporate grains with less than 6 sides.





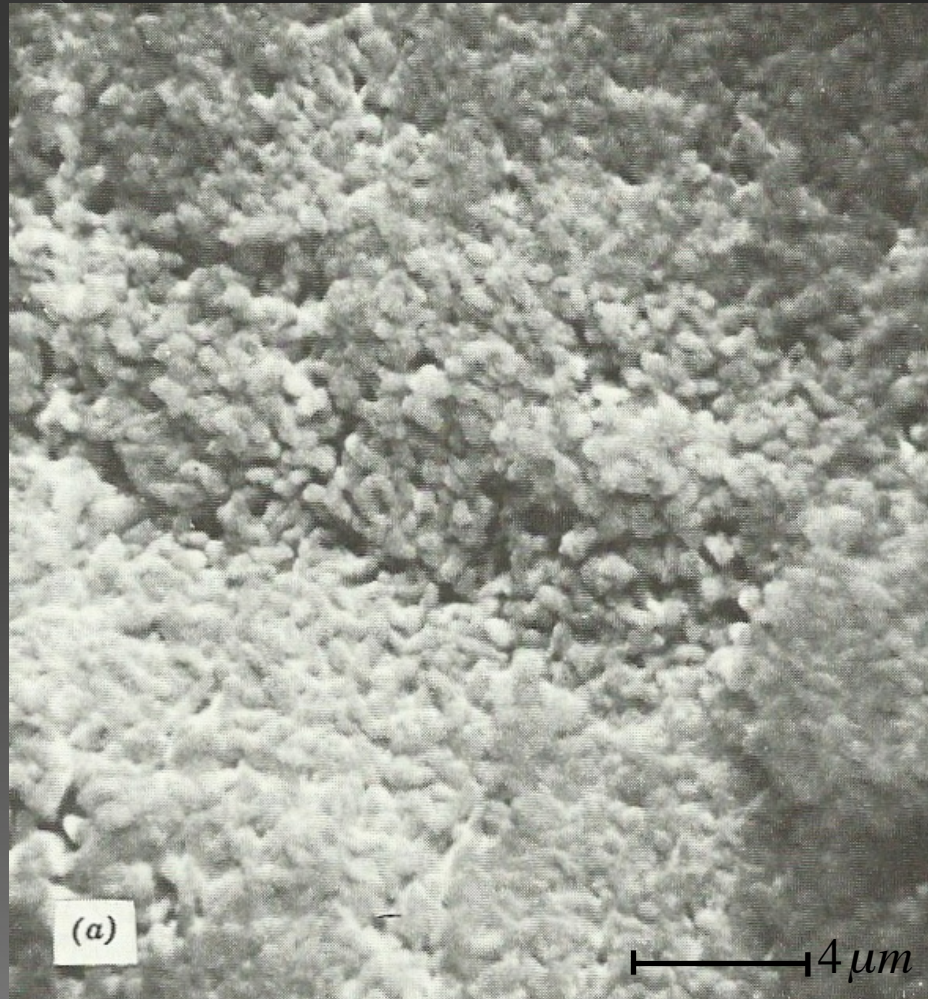
Growth of a large Al₂O₃ crystal into a matrix of uniformly sized grain.



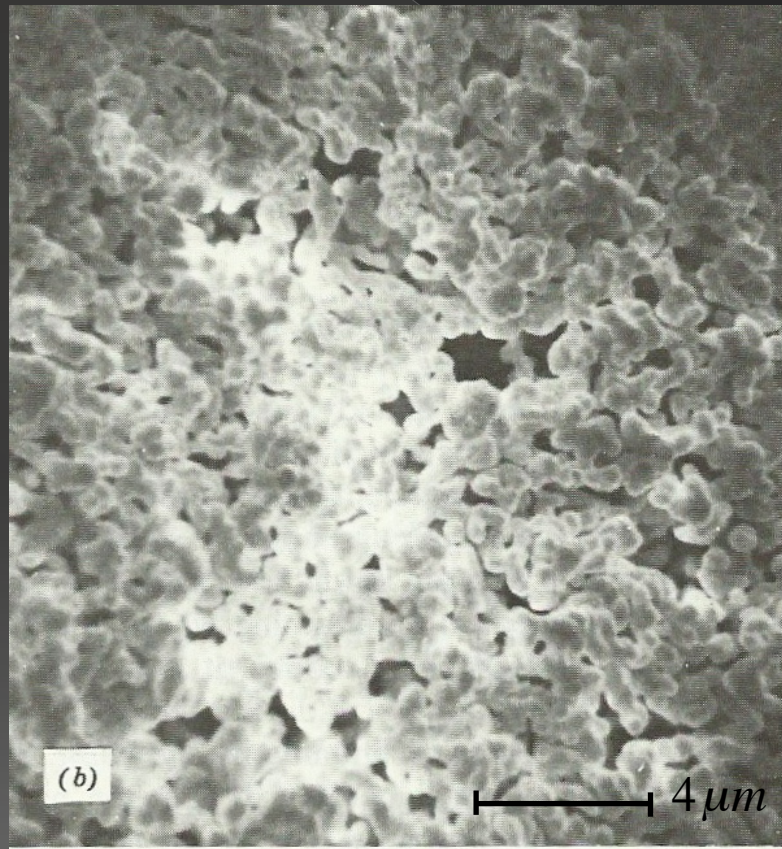
Polycrystalline fluorite CaF₂ illustrating normal grain growth

PROGRESSIVE DEVELOPMENT OF MICROSTRUCTURE IN *LUCALOX* ALUMINA

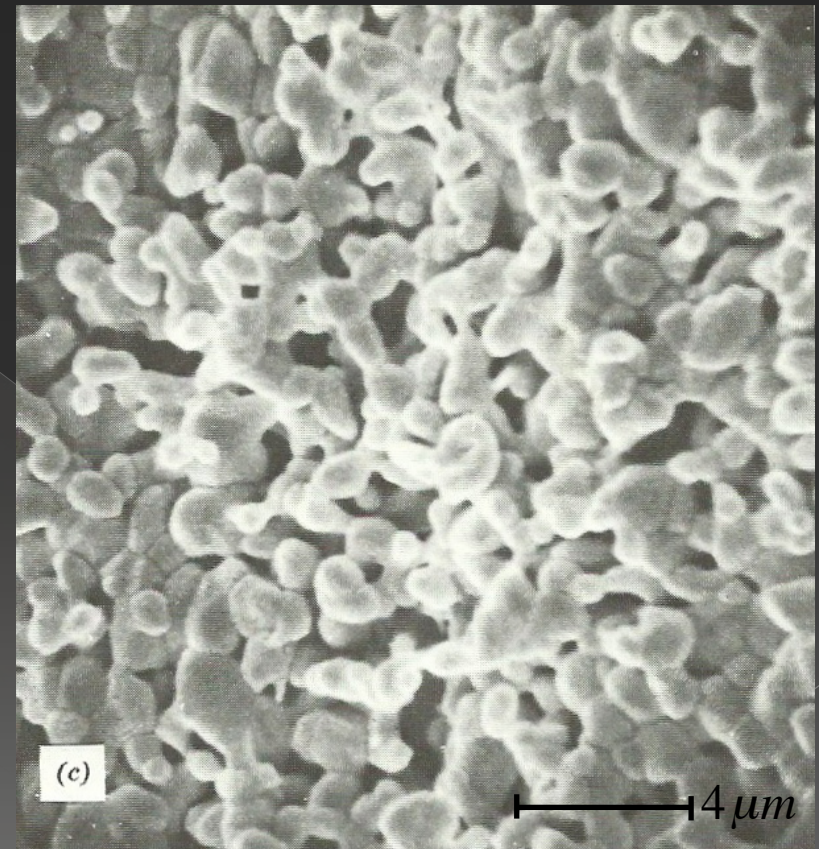
a) SEM of initial particles before sintering (5000x)



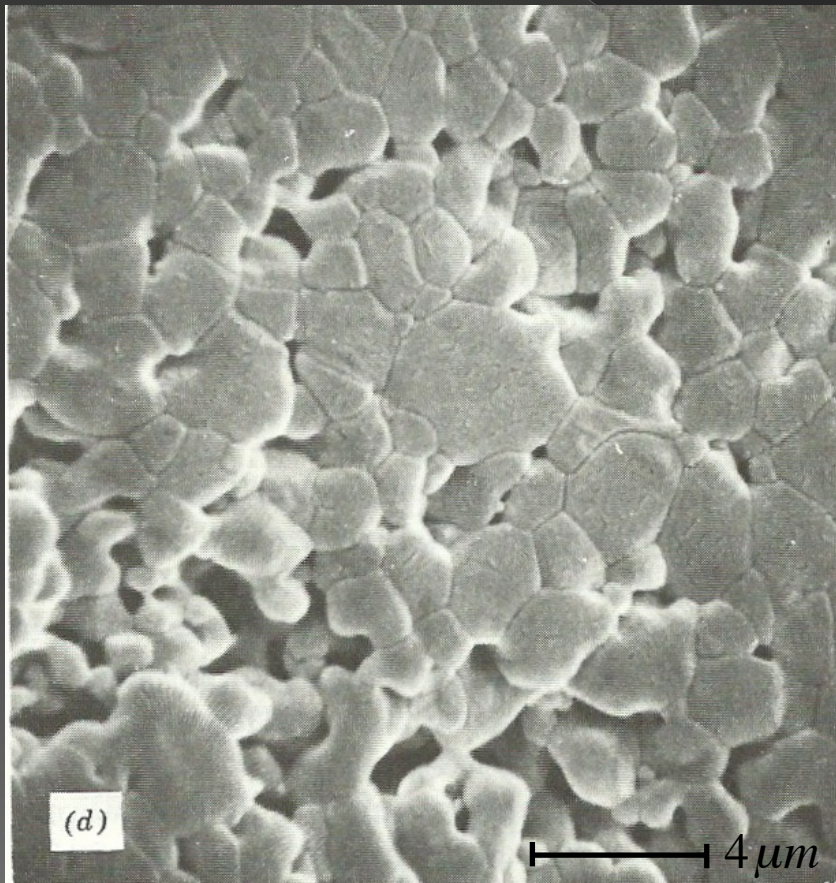
b) SEM of particles after 1 minute
at 1700°C (5000x)



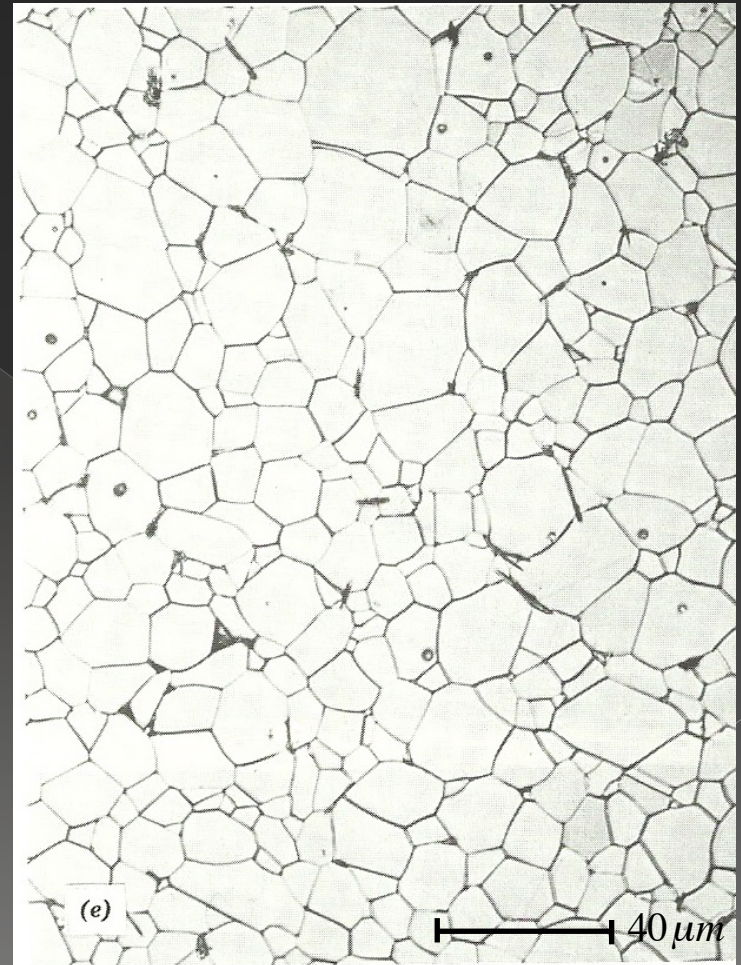
c) SEM of particles after 2
minutes at 1700°C (5000x)



d) SEM of particles after 6 minutes at 1700°C (5000x)

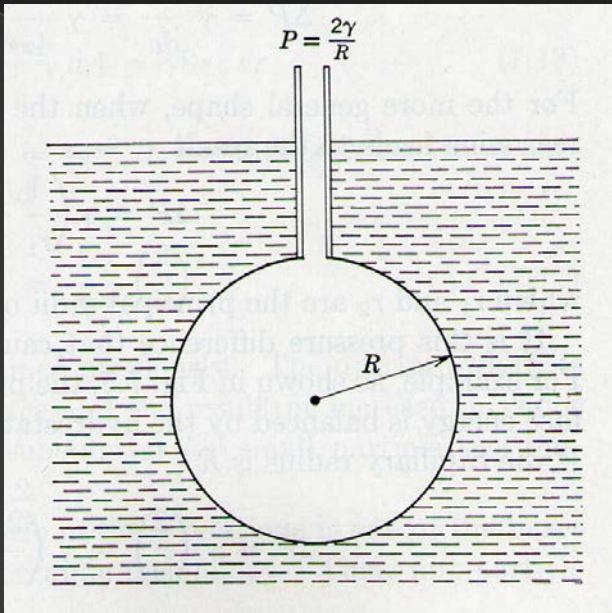


e) SEM of the final microstructure that is nearly porefree, with only a few pores located within grains (500x)



PRESSURE DIFFERENCE ACROSS A CURVED SURFACE

- The differences in the curvature of surface, causes a *pressure difference* in the various part of system, that leads to atoms transport.
- At the surface of the particle there is a *positive radius* of curvature, so that the vapour pressure is larger than would be observed in a flat surface.
- At the junction between particles there is a NECK with a small *negative radius* of curvatures and a vapour pressure lower than that for the particle itself.



P : Supplementary pressure to create the bubble.

γ : surface tension

SPHERICAL MODEL:

$$A = 4\pi R^2 \quad V = \frac{4}{3}\pi R^3$$

$$pdV = \gamma_{LV}dA$$

$$\Delta p 4\pi R^2 dR = \gamma_{LV} 8\pi R dR$$

$$\Delta p = \frac{2\gamma_{LV}}{R}$$

GENERICALLY:

$$\Delta p = \gamma_{LV} \left(\frac{1}{R_1} + \frac{1}{R_2} \right)$$



in equilibrium condition

$$p^\circ = K_e = e^{-\frac{\Delta G^0}{RT}}$$

vapour pressure of water
in a flat liquid-vapour interface

If the liquid-vapour interface is not flat, as in a small drops, the water has a vapour pressure that is larger than that in a flat surface:

$$e^{-\frac{\Delta G}{RT}} = e^{-\frac{\Delta G^0}{RT}} e^{-\frac{\bar{V}\Delta P}{RT}}$$

$$P_{H_2O} = P_{H_2O}^0 e^{-\frac{2\gamma\bar{V}}{rRT}}$$

$P_{H_2O}^0$: standard vapour pressure

Δp for water drops of different radii at **STP**

Droplet radius	1 mm	0.1 mm	1 μm	10 nm
Δp (atm)	0.0014	0.0144	1.436	143.6

ENERGY SURFACE

in a densification process in which the only energy is given by radius of curvature:

$$\bar{V} = \frac{MW}{\rho}$$

$$N = \frac{3MW}{4\pi a^3 \rho} = \frac{3\bar{V}}{4\pi a^3}$$

$$S_A = 4\pi a^2 N = \frac{4\pi a^2 3MW}{4\pi a^3 \rho} = 3 \frac{\bar{V}}{a}$$

$$E_s = S_A \gamma = \frac{3\bar{V}\gamma}{a}$$

$$\bar{V} : \text{molecular volume} \quad \frac{\text{cm}^3}{\text{mol}}$$

$$\rho : \text{density} \quad \frac{\text{g}}{\text{cm}^3}$$

$$a : \text{particle radius} \quad \approx \mu\text{m}$$

$$N : \text{number of particles in a mole of powder}$$

$$S_A : \text{surface area} \quad \text{m}^2$$

$$E_s : \text{surface energy} \quad \frac{\text{J}}{\text{mol}}$$

$$\gamma : \text{surface tension} \quad \approx 1 \frac{\text{J}}{\text{m}^2}$$

$$MW : \text{molecular weight} \quad \frac{\text{g}}{\text{mol}}$$

- Energy available without added pressure in a sintering pocess of alumina:

$$E_s = \frac{3\bar{V}\gamma}{a} = 75 \frac{J}{mol}$$

- Energy available with added pressure in the same sintering:

$$w = P_A \bar{V} = 750 \frac{J}{mol}$$

$$P = 30 \text{ Mpa}$$

$$\bar{V}_{Al_2O_3} = 25 \cdot 10^{-6} \frac{m^3}{mol}$$

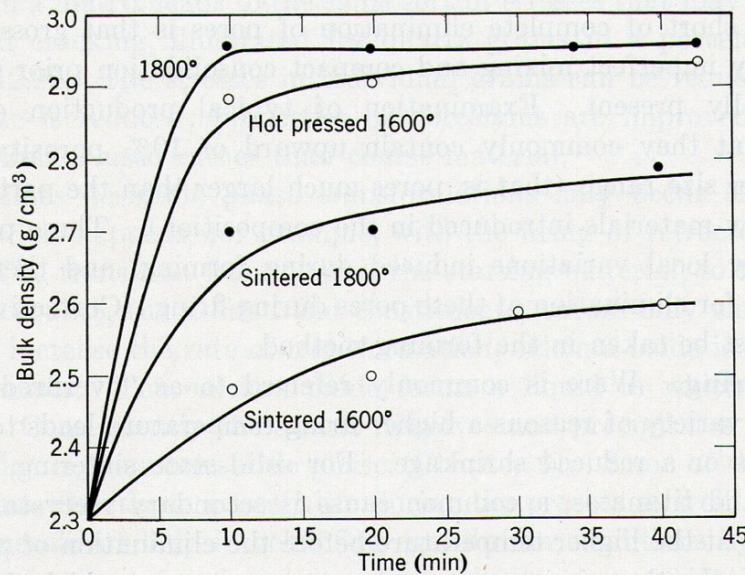


Fig. 12.30. Densification of beryllia by sintering and by hot pressing at 2000 psi.

Image from Kingery

DIFFUSION AND MOBILITY:

true in the absence of friction:

$$F = ma$$

otherwise:

$$F = m \frac{dv}{dt} + \frac{v}{M}$$

Einstein's generalized equation of mobility:

$$D = MRT$$

$\frac{v}{M}$: friction coefficient

M : mobility

D : diffusion coefficient

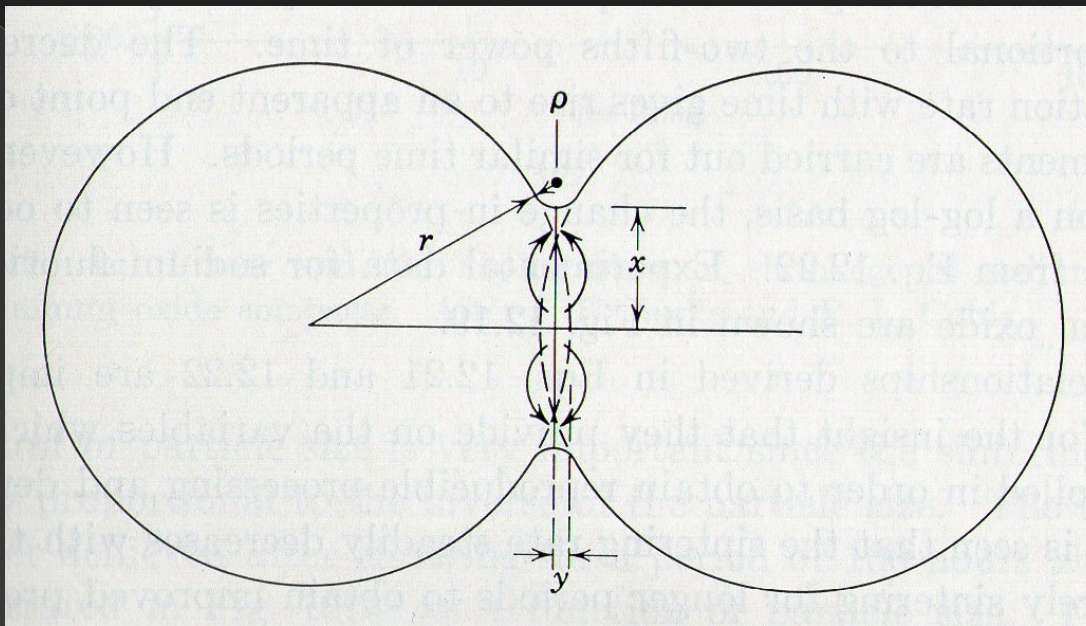
KINETIC MODELING OF SINTERING PROCESS

PARAMETERS TO DEFINE THE MODEL:

- define a *DRIVING FORCE*
- define the *GEOMETRY*
- define the *MECHANISM OF TRANSPORT*

STAGES OF THE SINTERING:

- *INITIAL STAGE* : from 50-55% to 75% of TD → *MODELING*
- *INTERMEDIATE STAGE* : from 75% to 92% of TD
- *FINAL STAGE* : from 92% to 100% of TD



ρ : radius of the neck's curvature

r : radius of particle

x : parameter indicated the progress of the sintering

GEOMETRY

$$(r + \rho)^2 = (r - \rho)^2 + (x + \rho)^2$$

$$\rho = \frac{x^2}{4r}$$

$$A_{Neck} = 2\pi x \cdot \pi\rho = \frac{\pi^2 x^3}{2r}$$

$$V_{Neck} = \frac{\pi x^4}{8r}$$

Approximations :

$$\rho^2 = 0$$

$$x\rho = 0$$

FLUX

The material transfer is linked to the flux.

Considering the area through which the transport takes (the neck area):

$$J = \frac{1}{A_{Neck}} \frac{d}{MW} \frac{dV_{Neck}}{dt}$$

d : density

MW : molecular weight

J : flux

$$\frac{dV_{Neck}}{dt} = \frac{4\pi x^3}{8r} \frac{dx}{dt} = \frac{\pi x^3}{2r} \frac{dx}{dt}$$

Variation of the neck volume
based on the increase of the
'x' parameter:

$$J = \frac{2r}{\pi^2 x^3} \frac{d}{MW} \frac{\pi x^3}{2r} \frac{dx}{dt} = \frac{1}{\pi V} \frac{dx}{dt}$$

FLUX expressed as a DRIVING FORCE

$$J = cMF$$

c : concentration

M : mobility of bulk and grain boundary atoms

F : force

$$M = \frac{D}{RT}$$

$$J = cMF$$

$$F = -\nabla G = -\frac{dG}{dx} \approx \frac{dG}{\rho}$$

Variation of the free energy during the diffusion on the neck area:

$$\Delta G = \Delta p \bar{V} = \bar{V} \gamma \left(\frac{1}{r_1} + \frac{1}{r_2} \right) = \bar{V} \gamma \left(\frac{1}{x} - \frac{1}{\rho} \right) = \frac{\bar{V} \gamma}{\rho}$$

$$F = \frac{\Delta G}{\rho} = \frac{\bar{V} \gamma}{\rho^2}$$

$$J = cMF = c \frac{D}{RT} \frac{\bar{V}\gamma}{\rho^2}$$

$$\frac{1}{\bar{V}\pi} \frac{dx}{dt} = \frac{cD}{RT} \frac{\bar{V}\gamma}{x^4}$$

$$16r^2$$

integration between 0 and x

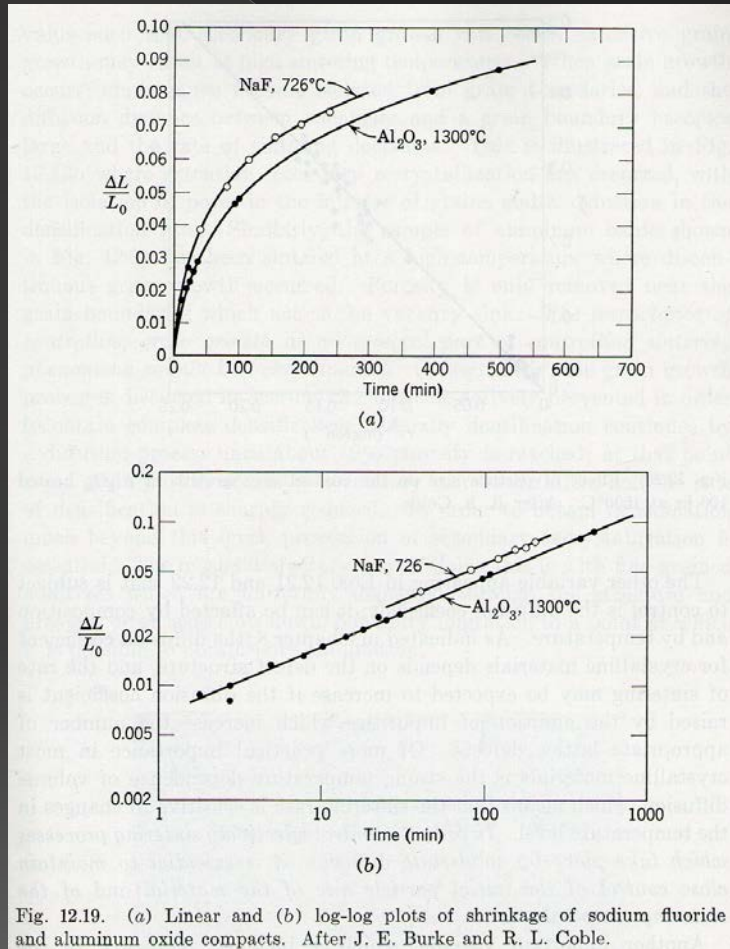
t=0, x=0

$$\frac{1}{5} x^5 = \frac{5\pi \bar{V}^2 c D \gamma r^2}{RT} t$$

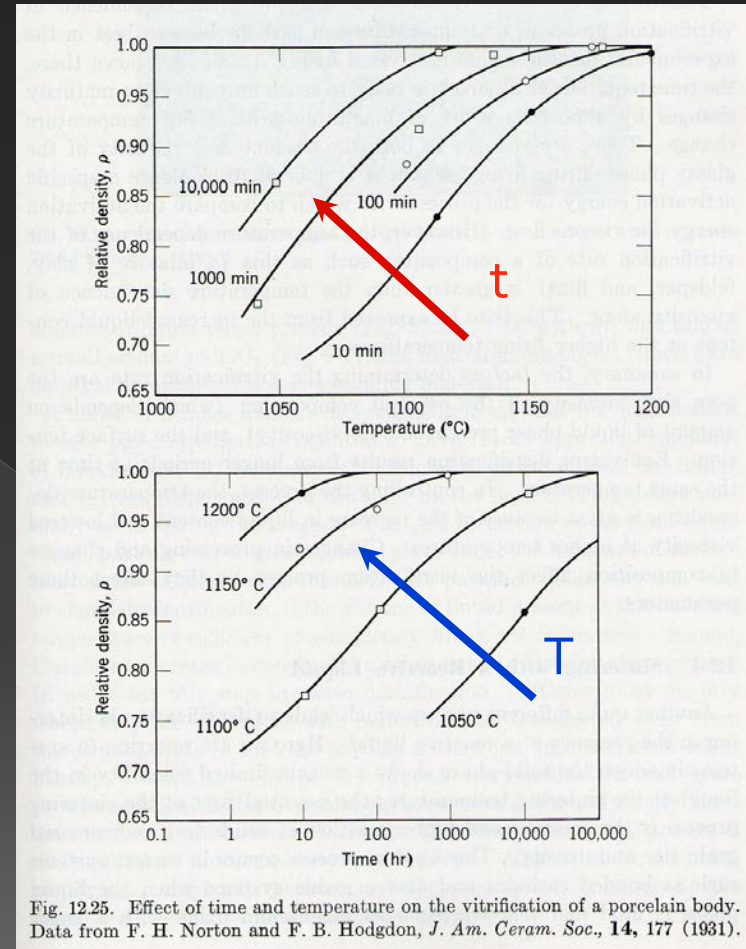
$$x = \left(\frac{5\pi \bar{V}^2 c D \gamma r^2}{RT} \right)^{\frac{1}{5}} t^{\frac{1}{5}}$$

t: sintering time

Variation of the volume of the particles in the sintering process during the time:



Variation of the relative density variatung time and temperature:



The increase of a few degrees in temperature has much more influence on the grain size than the increase of a one order of magnitude of the time

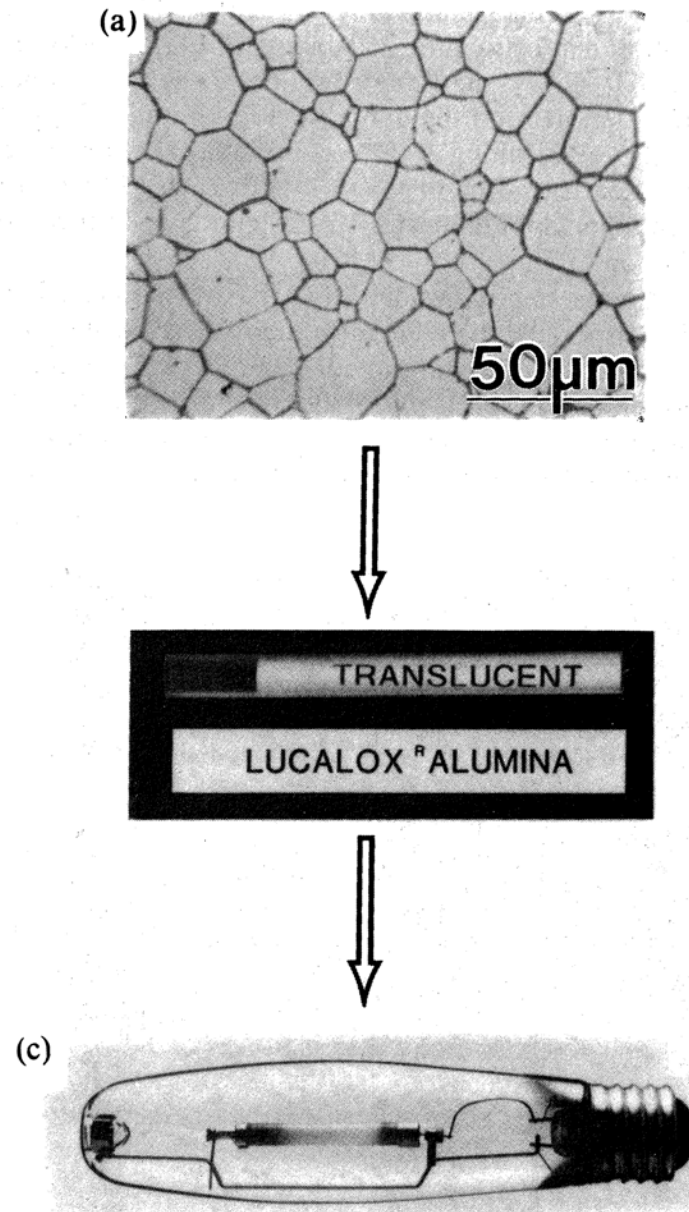


Figure 11.9 Comparison of the microstructure and translucency of relatively pore-free Al_2O_3 (a) with that of opaque Al_2O_3 containing pores trapped in grains (b). Translucent Al_2O_3 tubes are used in sodium vapor lamps that provide energy efficient street lights. (Courtesy of General Electric.)

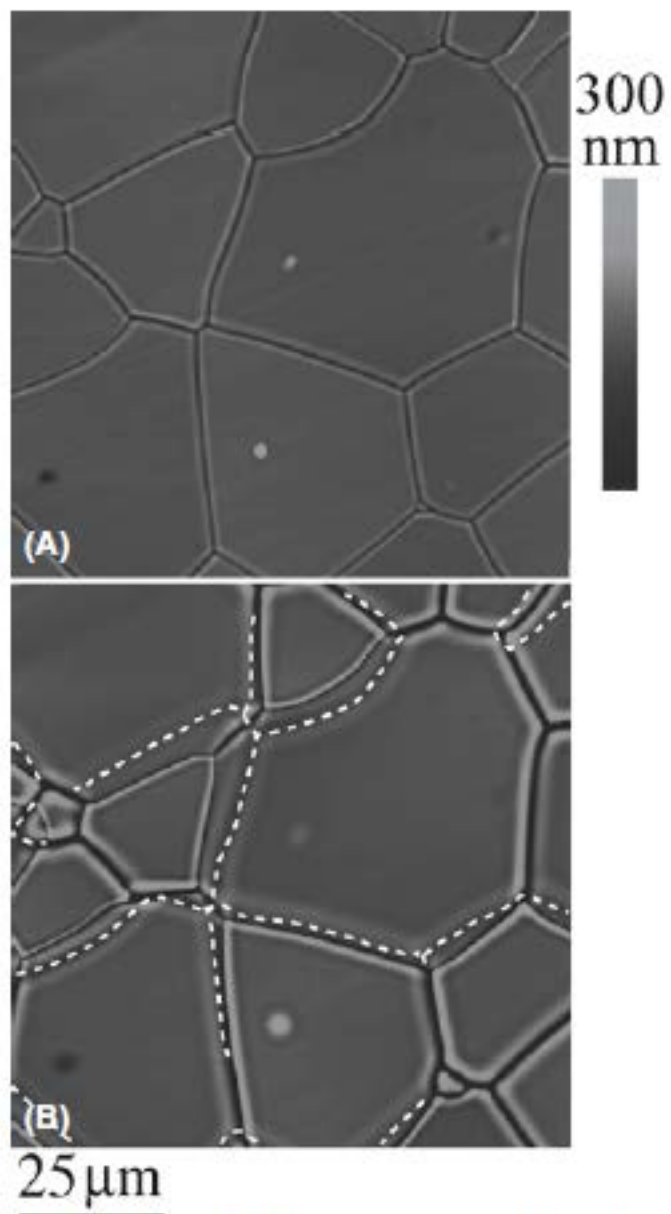


FIGURE 24.17 (a, b) AFM of grooves at migrating GBs

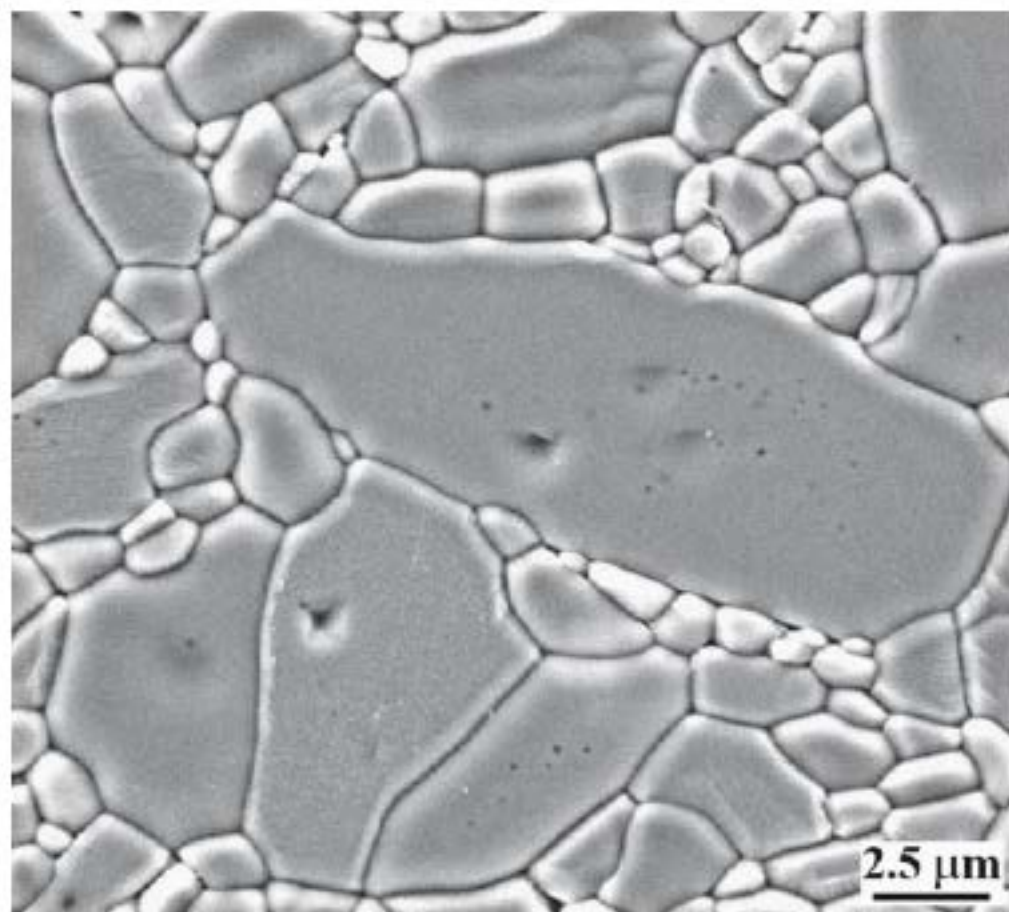
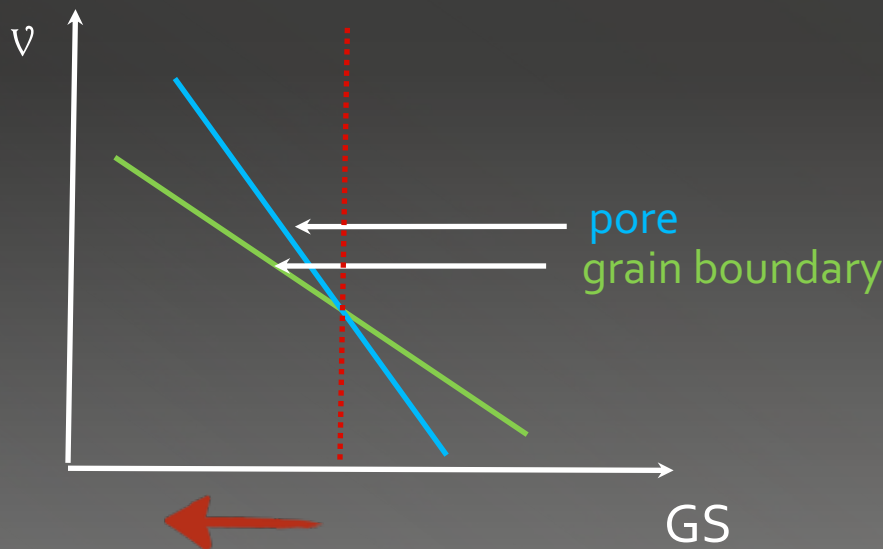


FIGURE 24.21 Elongated exaggerated grain in Al_2O_3 .

- During the growth, the larger grain leaves behind a lot of pores and the piece can not achieve the 100% of theoretical density (DT).
- To avoid the pore incorporation inside the grain, the speed of grain boundaries must be lower than that of the pores.
- Some impurities can segregate on grain boundary (*GRAIN BOUNDARY PINNING*) slowing the growth and so it's possible to achieve the 100% of DT.



$v_{\text{pore}} > v_{\text{grain boundary}}$

E.G. :

*ALUMINA 'LUCALOX':
polycrystalline Al_2O_3 - 1% MgO*

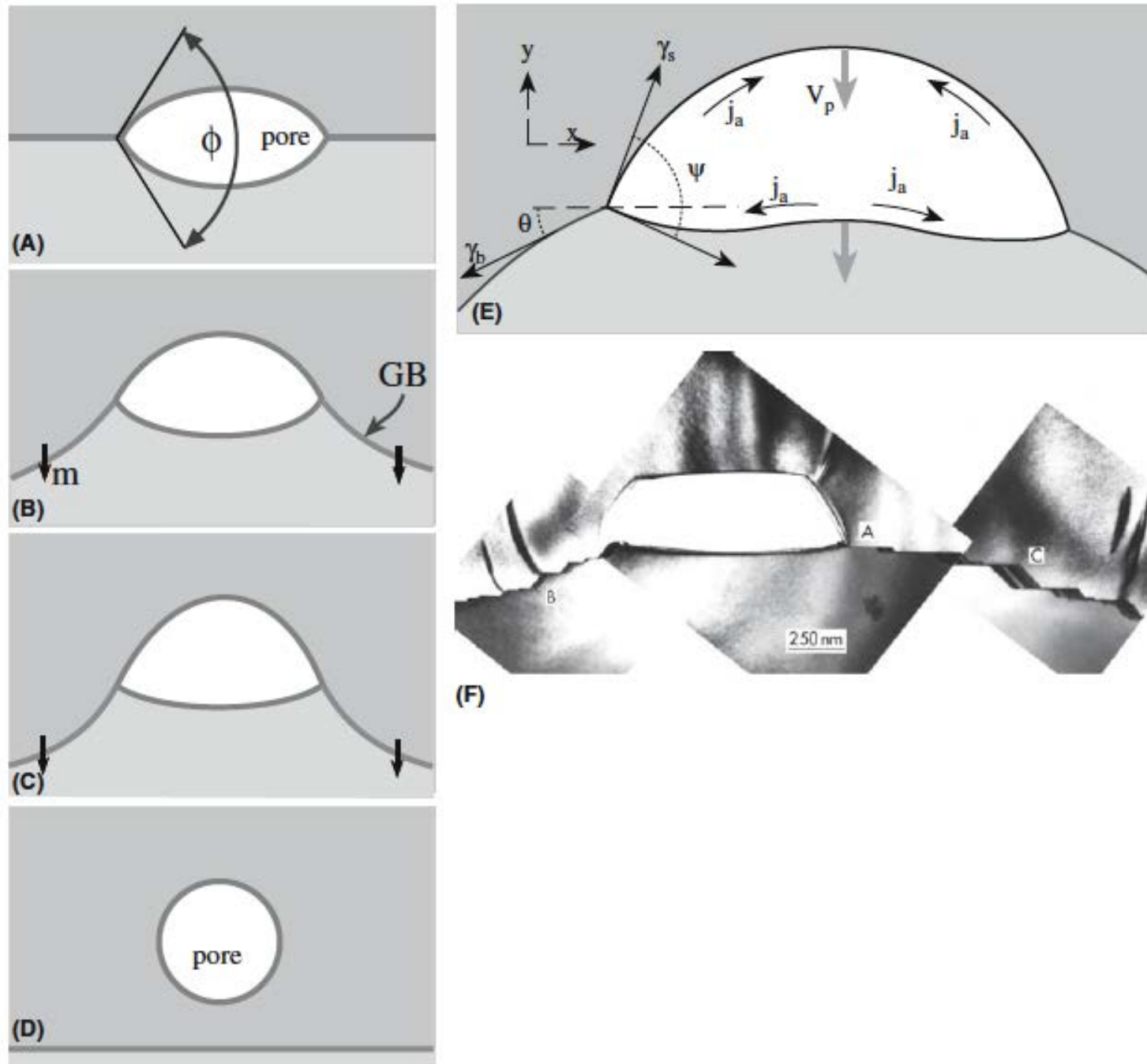
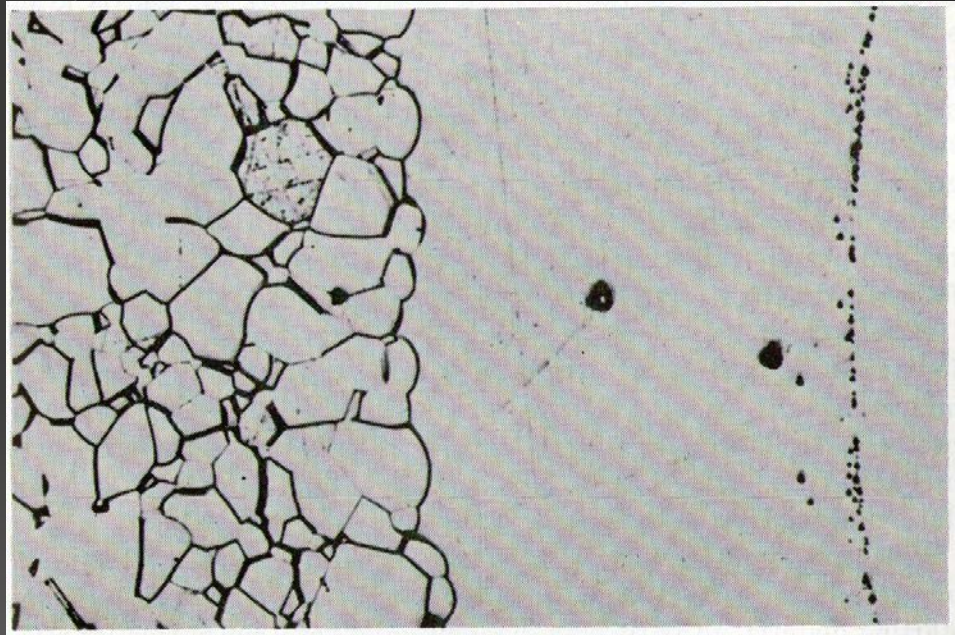


FIGURE 24.14 (a–e) GB/pore interaction: the break-away process.



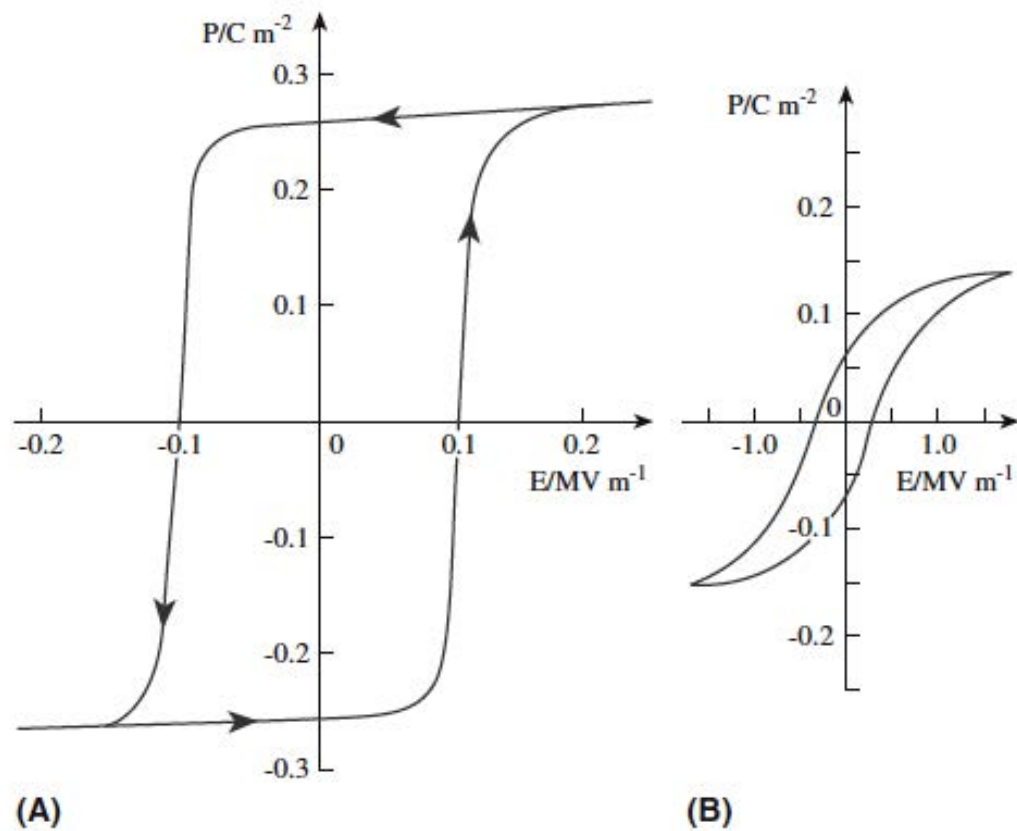


FIGURE 31.10 Hysteresis loops for BaTiO_3 . (a) Single-domain single crystal. (b) Polycrystalline ceramic.

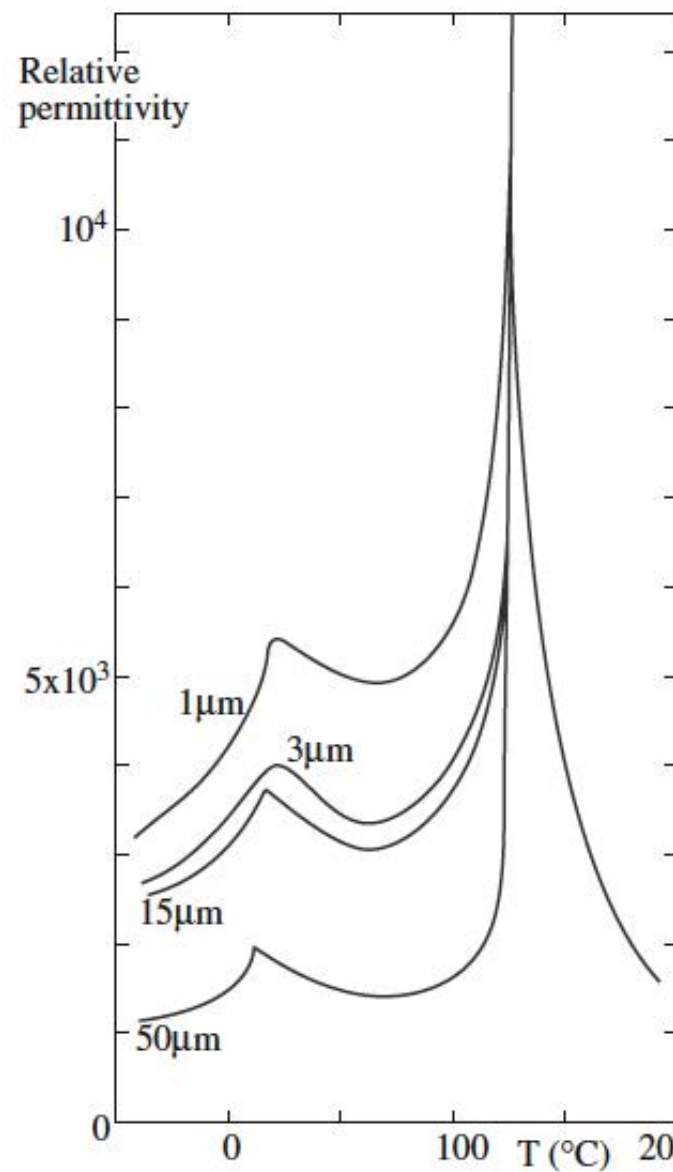


FIGURE 31.15 Effect of grain size on the dielectric constant of BaTiO_3 .

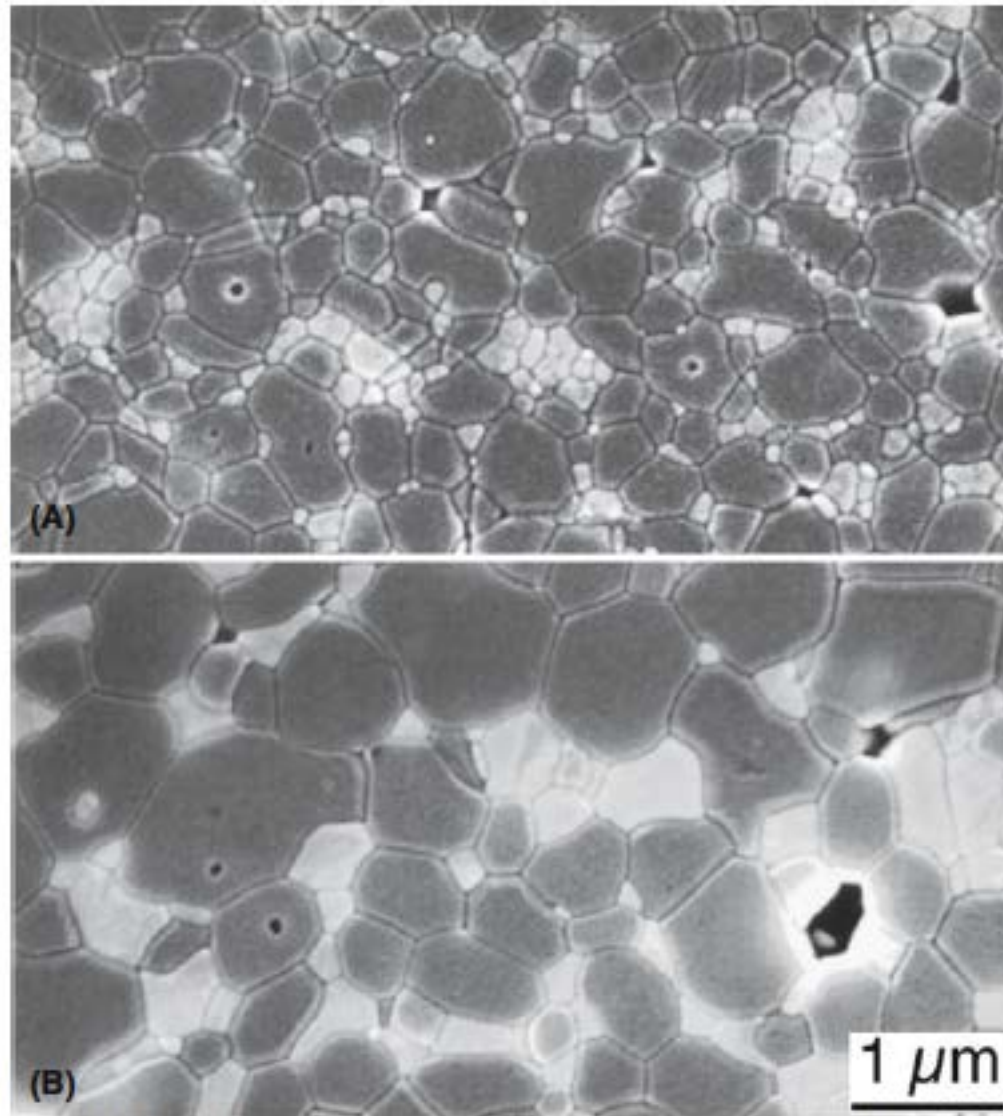
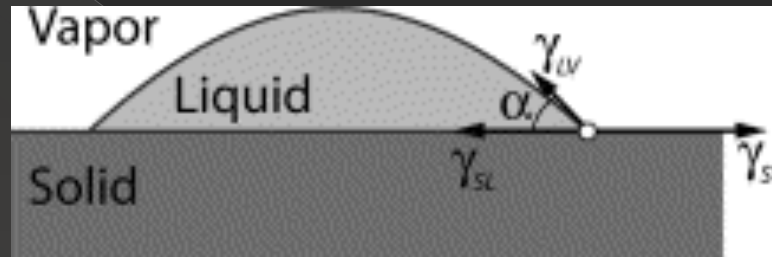


FIGURE 24.27 Two-phase ceramics. (a) As sintered and (b) heat treated at 1600°C for 30 hours. ZTA 30% (zirconia-toughened alumina with 30 vol% YSZ containing 10 molar% yttria).

WETTABILITY

Is the ability of a drop of liquid to recline on a solid surface.
Varying the pressure is changed the wettability.



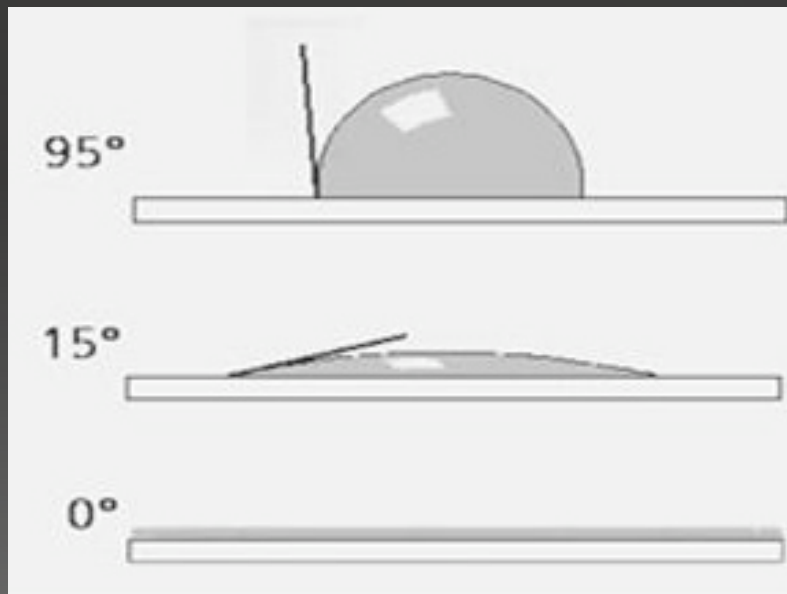
- α : contact angle
- γ_{LV} : liquid-vapour interfacial energy
- γ_{LS} : liquid-solid interfacial energy
- γ_{SV} : solid-vapour interfacial energy

The contact angle specifies the condition for minimum energy, according to the relation:

$$\gamma_{SL} + \gamma_{LV} \cos \alpha = \gamma_{SV}$$

$$\cos \alpha = \frac{\gamma_{SV} - \gamma_{SL}}{\gamma_{LV}}$$

possible cases:



$\alpha > 90^\circ \longrightarrow$ non-wettability

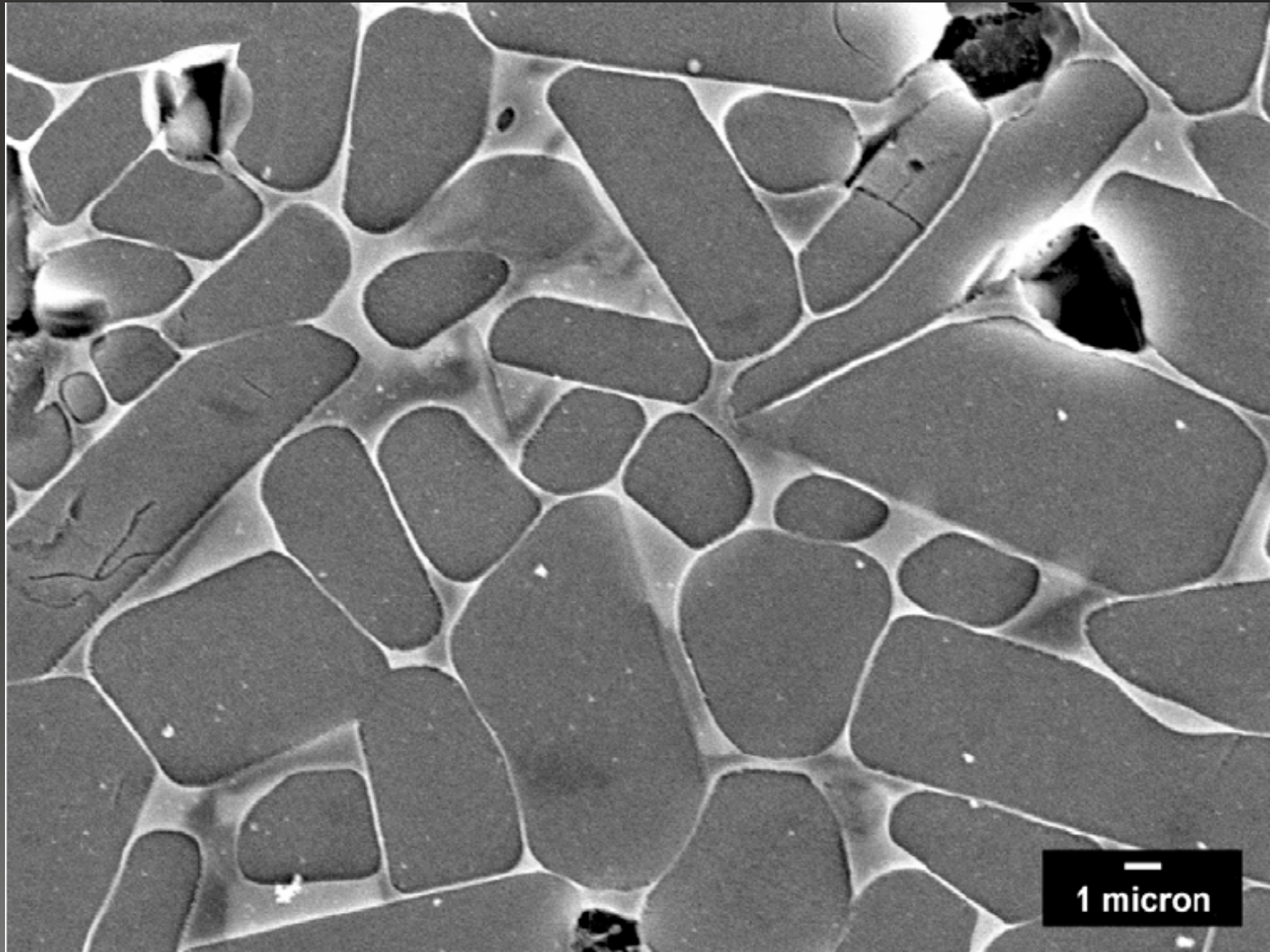
$\alpha < 90^\circ \longrightarrow$ wettability

$\alpha = 0 \longrightarrow$ spreading

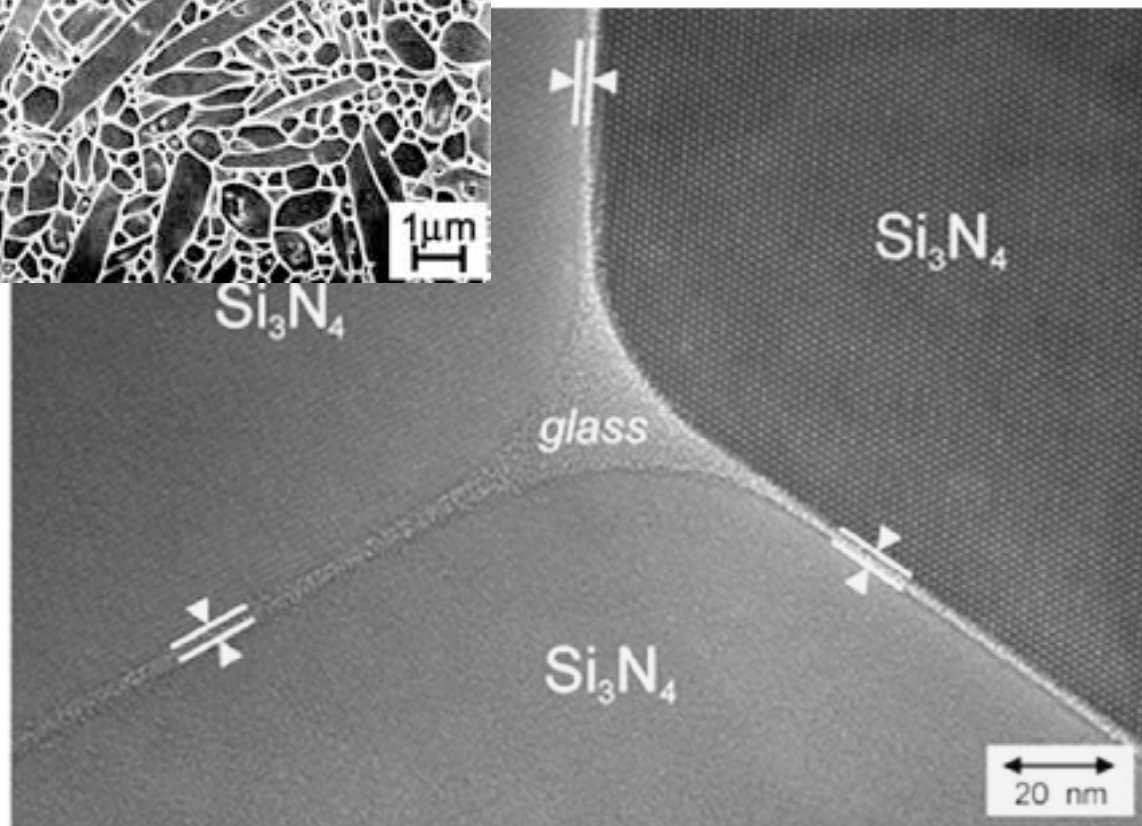
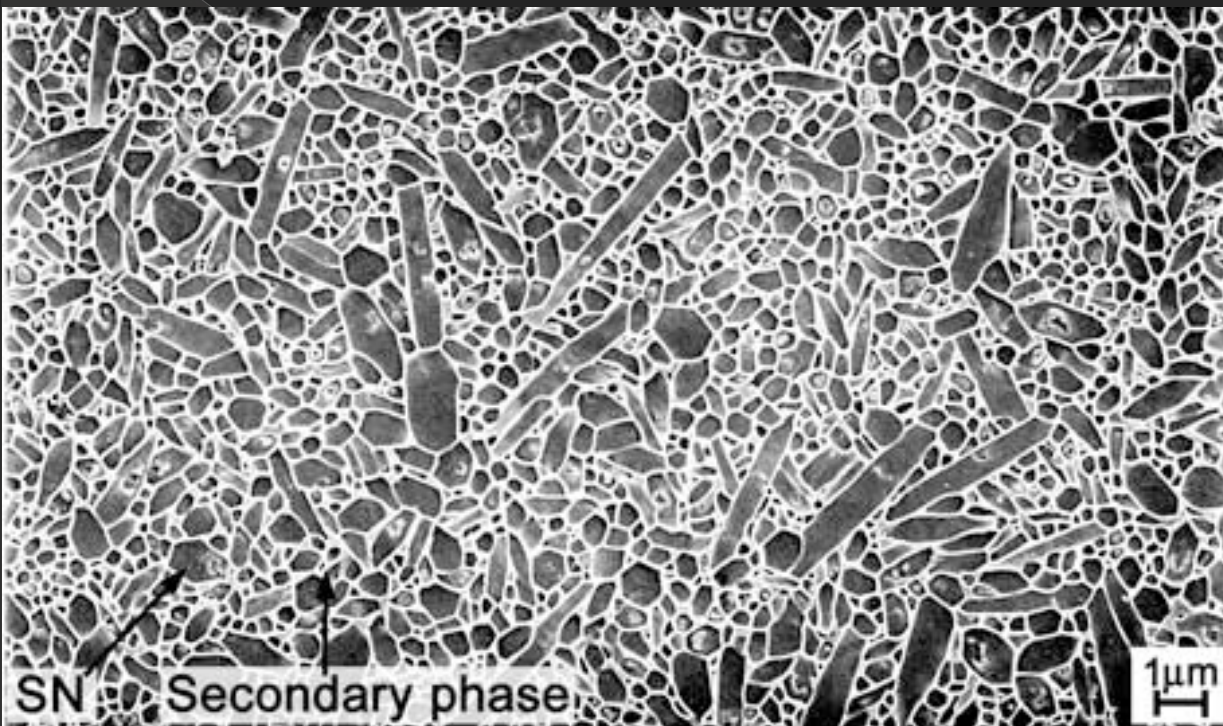
LIQUID PHASE SINTERING

- It is the process of adding an additive to the powder which will melt before the ceramic grains.
- The metal added, at high temperatures, melt and WET the grains. The intergranular spaces are such as to have a capillary forces which attract the grain one another.
- (By lowering the temperature, the amorphous phase does not wet the grains anymore and ritires in triple junctions.)
- (This gives good mechanical proprieties.)
- E.G. : WIDIA (93% WC in a Co matrix).

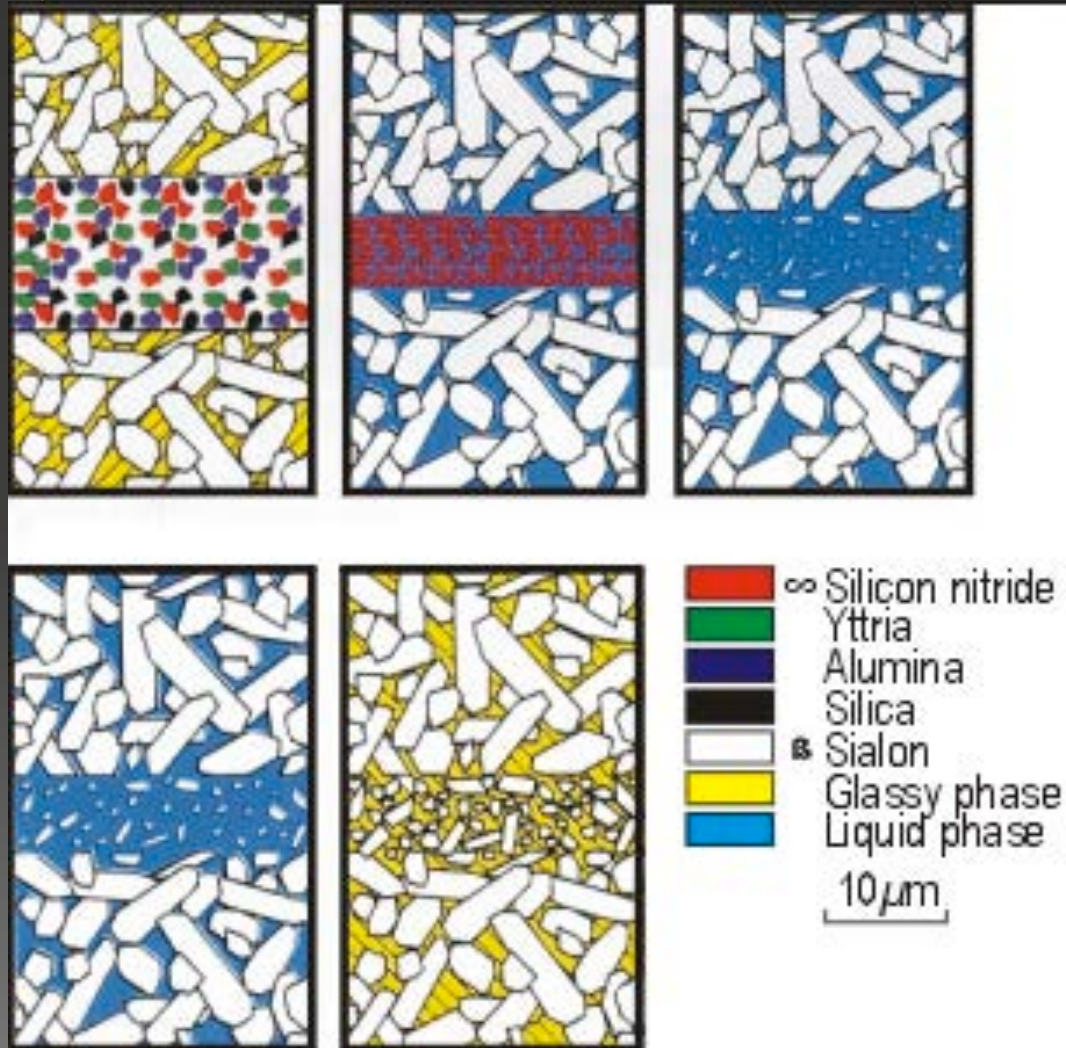
Liquid phase sintered SiC



Liquid phase sintered Si_3N_4



Liquid phase sintered SiAlON



Ni

(111)

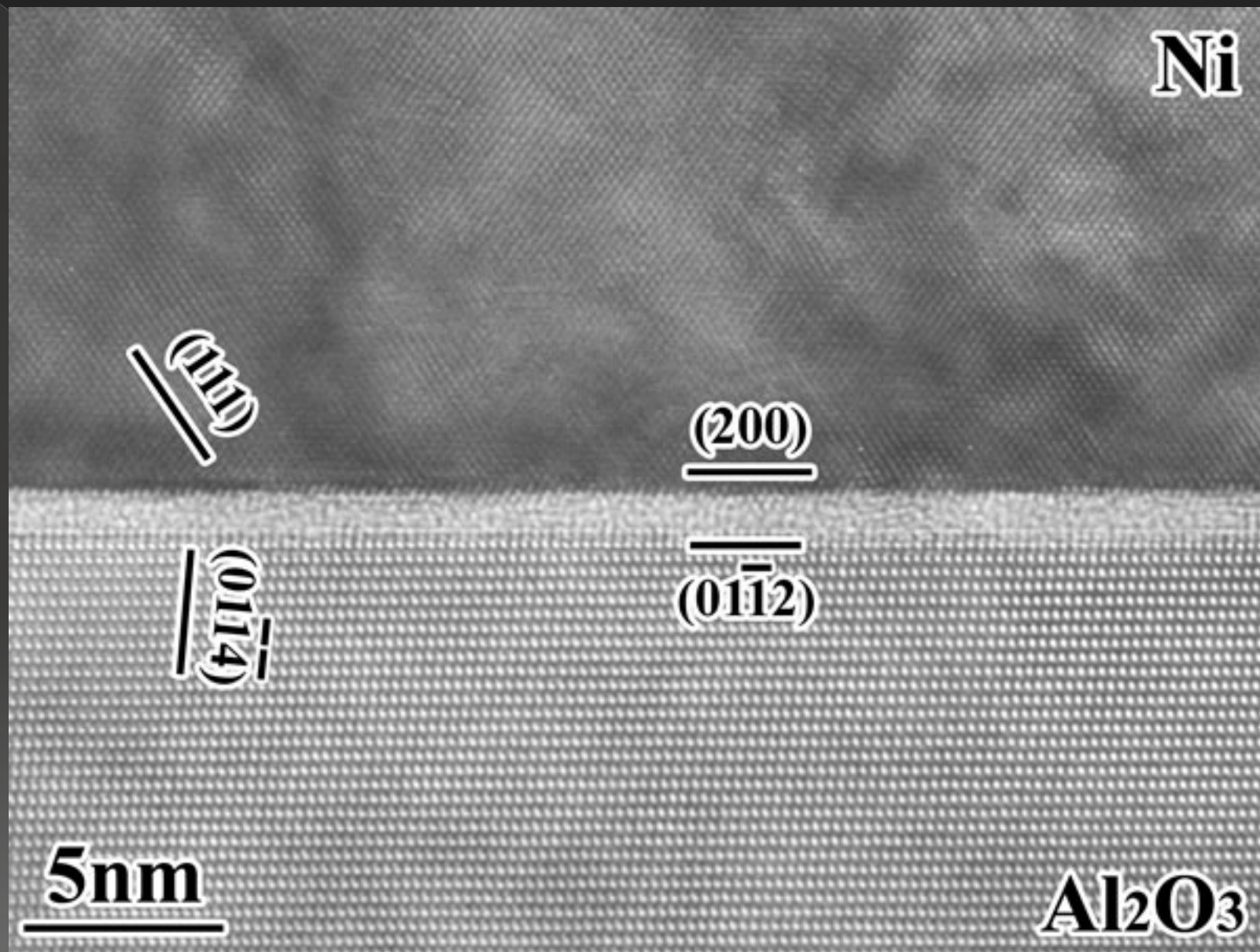
(200)

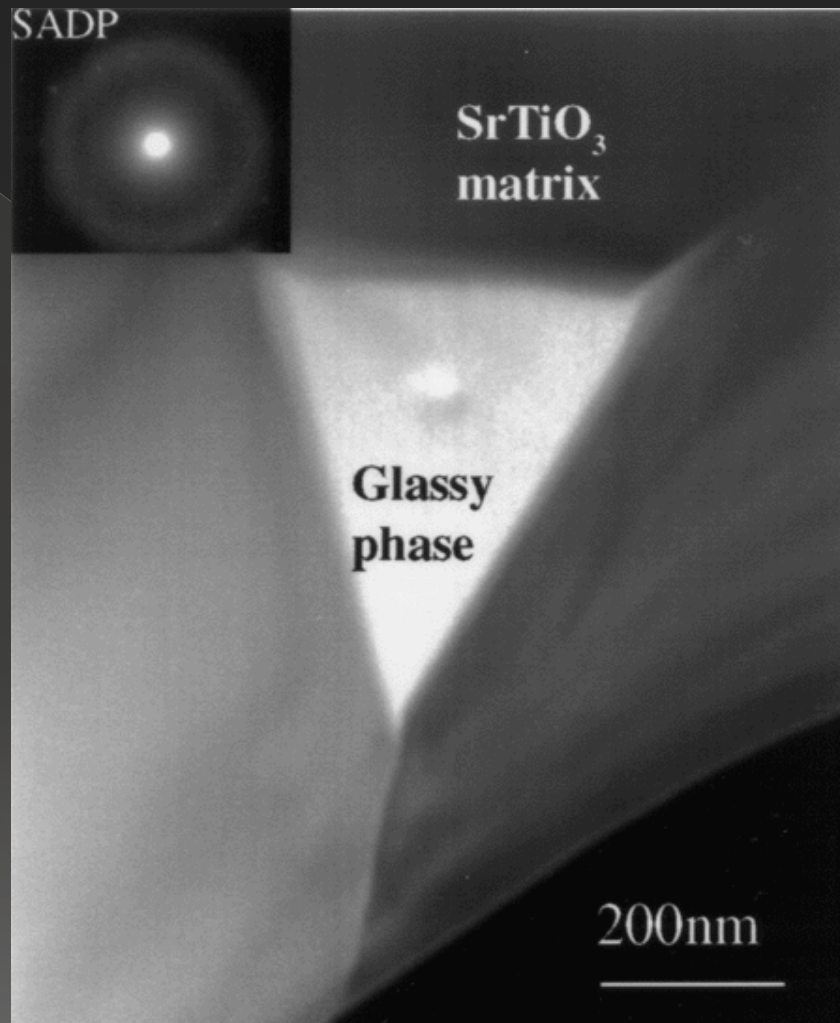
$(01\bar{1}4)$

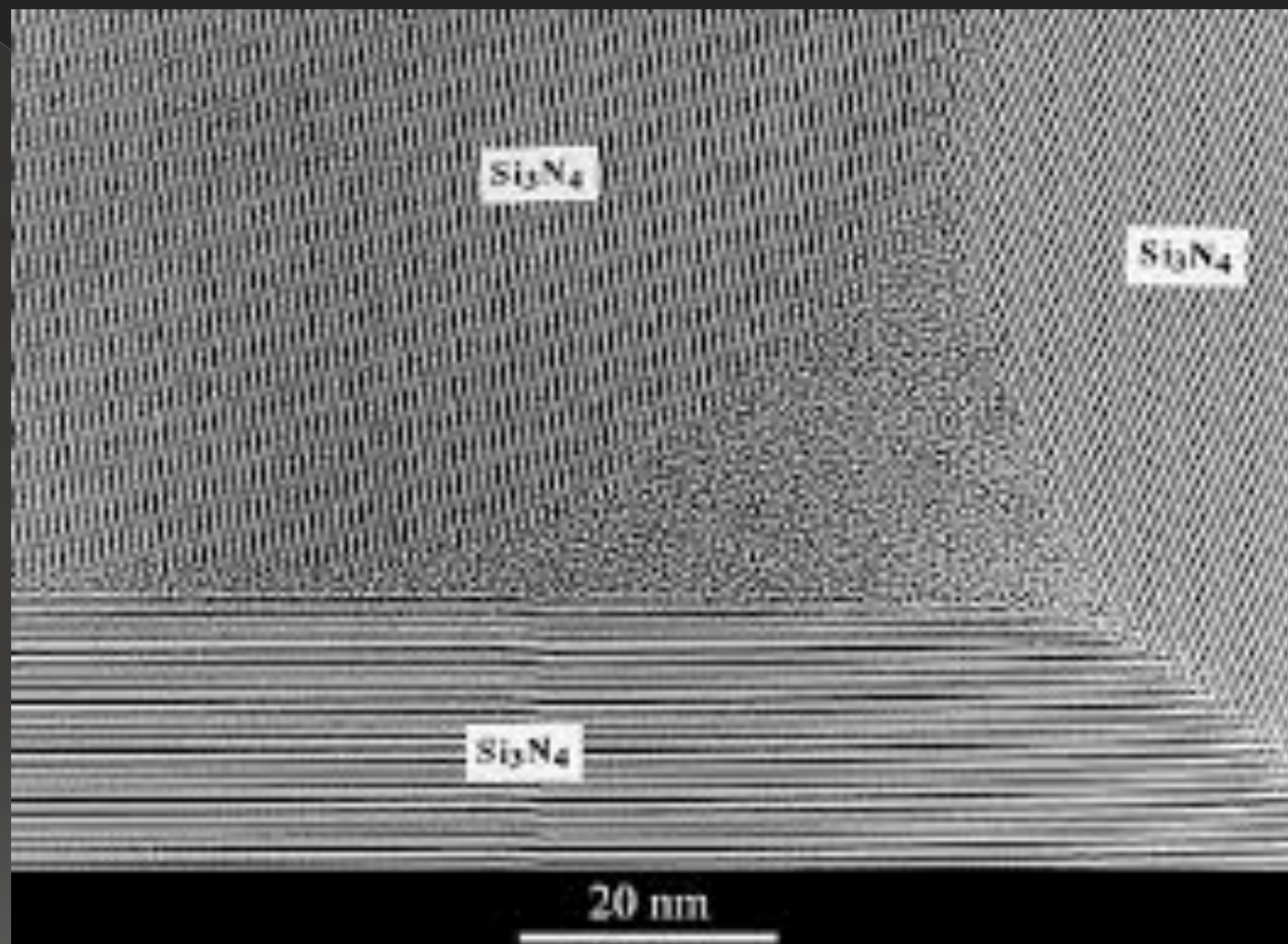
$(01\bar{1}2)$

5nm

Al_2O_3







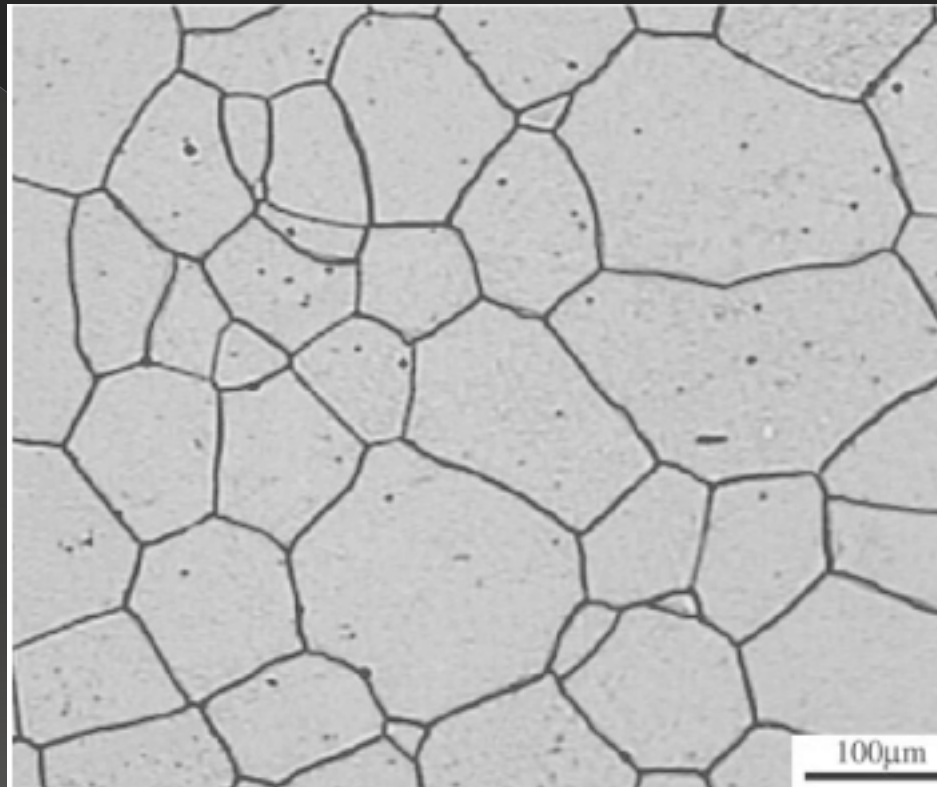
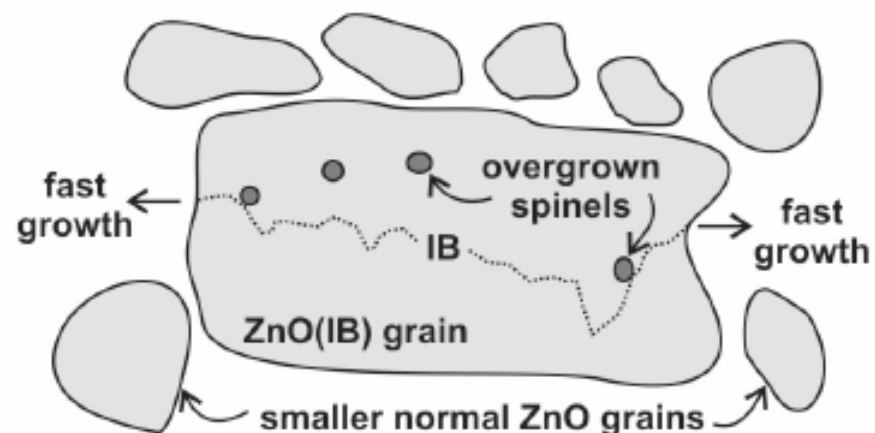
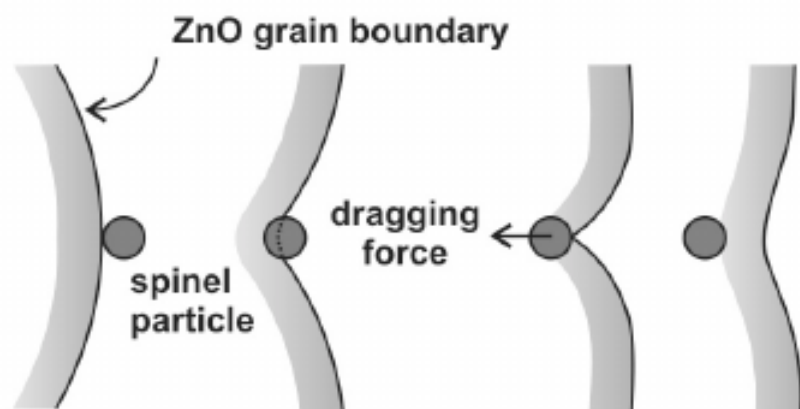
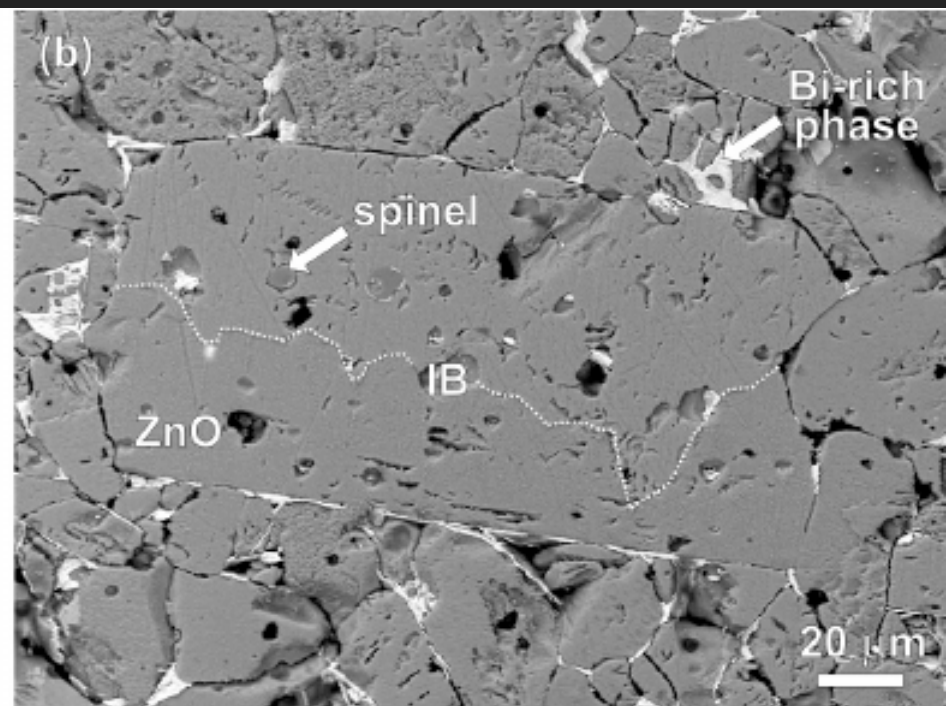
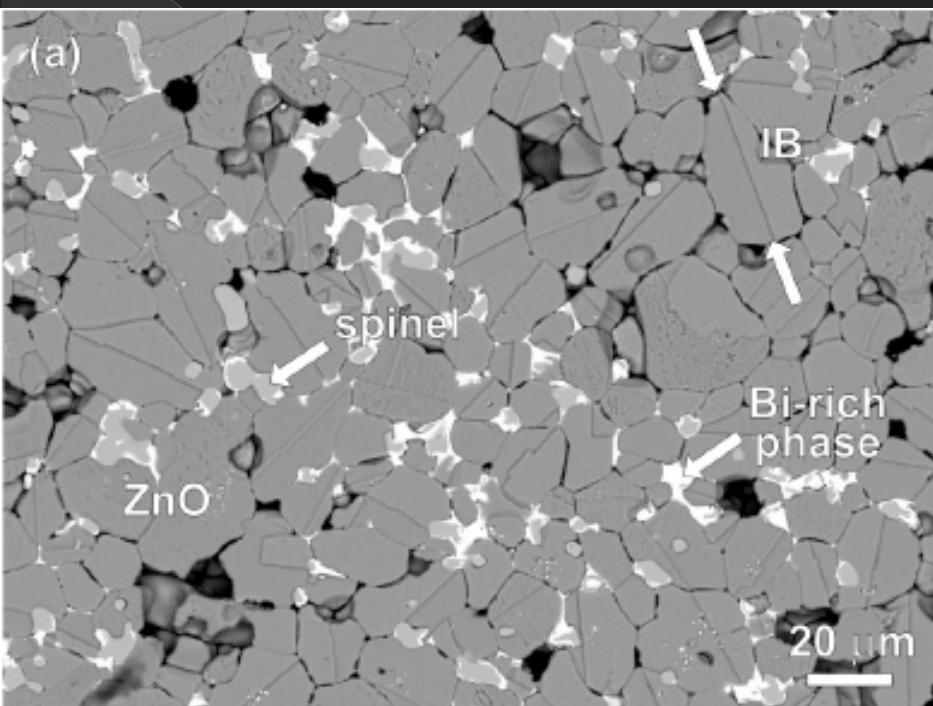


Figure 1. Typical microstructure of polycrystalline ZnO used in this work, after thermal etching at 1150 °C, for 1 h, in air.



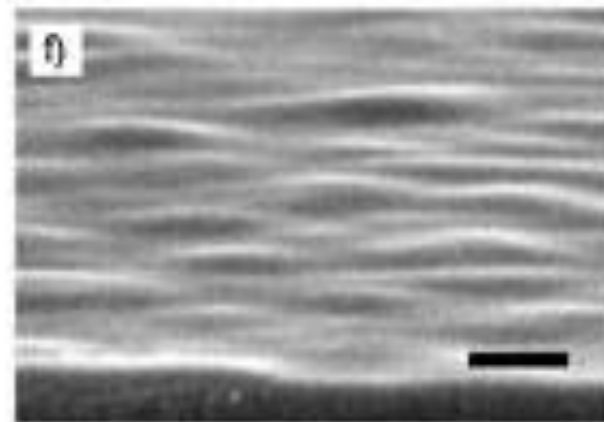
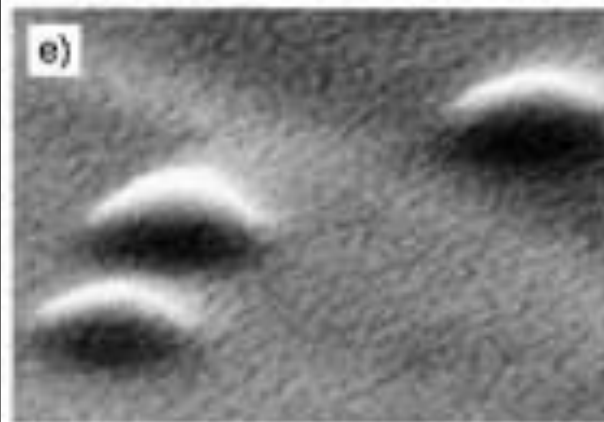
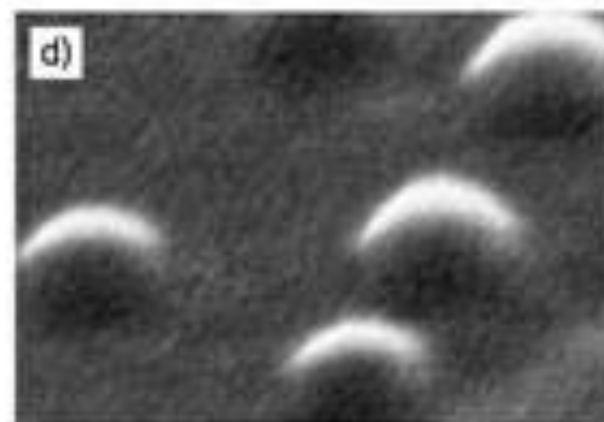
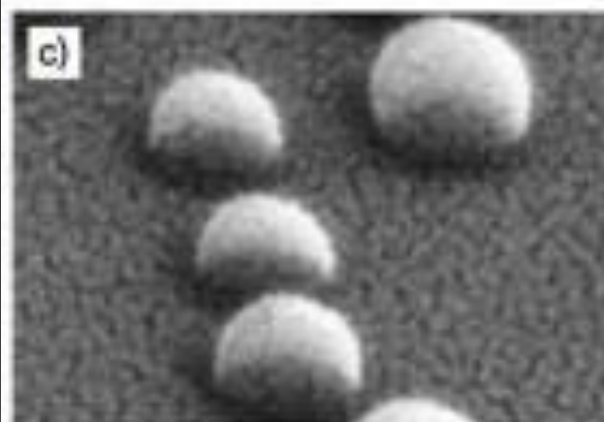
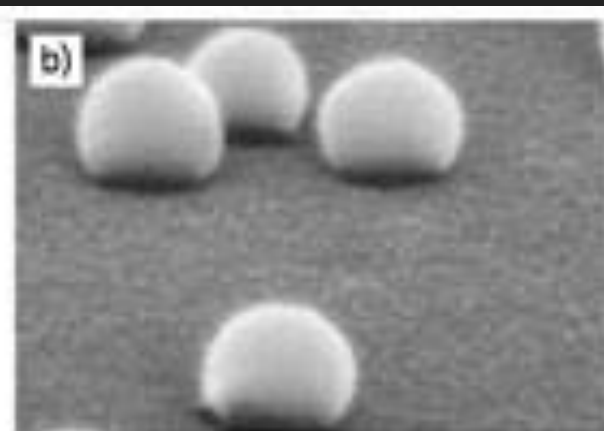
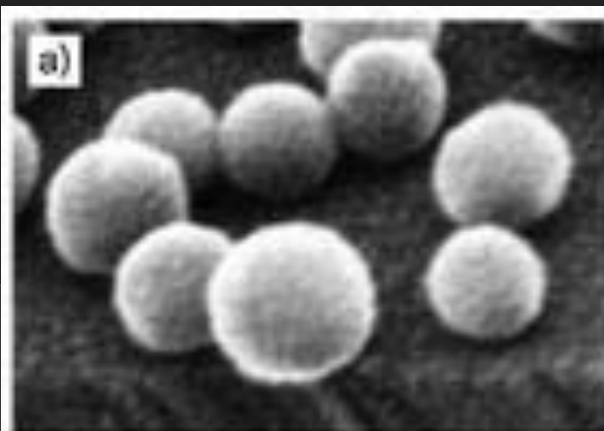
PROCEDURE FOR THE SINTERING PROCESS

- Determination of the T_m $T_{\text{sintering}} = 2/3 T_m$ E.G.: Al_2O_3
 $T_m = 2400^\circ\text{C}$ $T_{\text{sintering}} = 1600^\circ\text{C}$
- CALCINATION (200°C - 300°C under the sintering temperature)
E.G.: ZrO_2 stabilized by CaO , Y_2O_3 , CeO_2
- FORMING the ceramic parts
- SINTERING

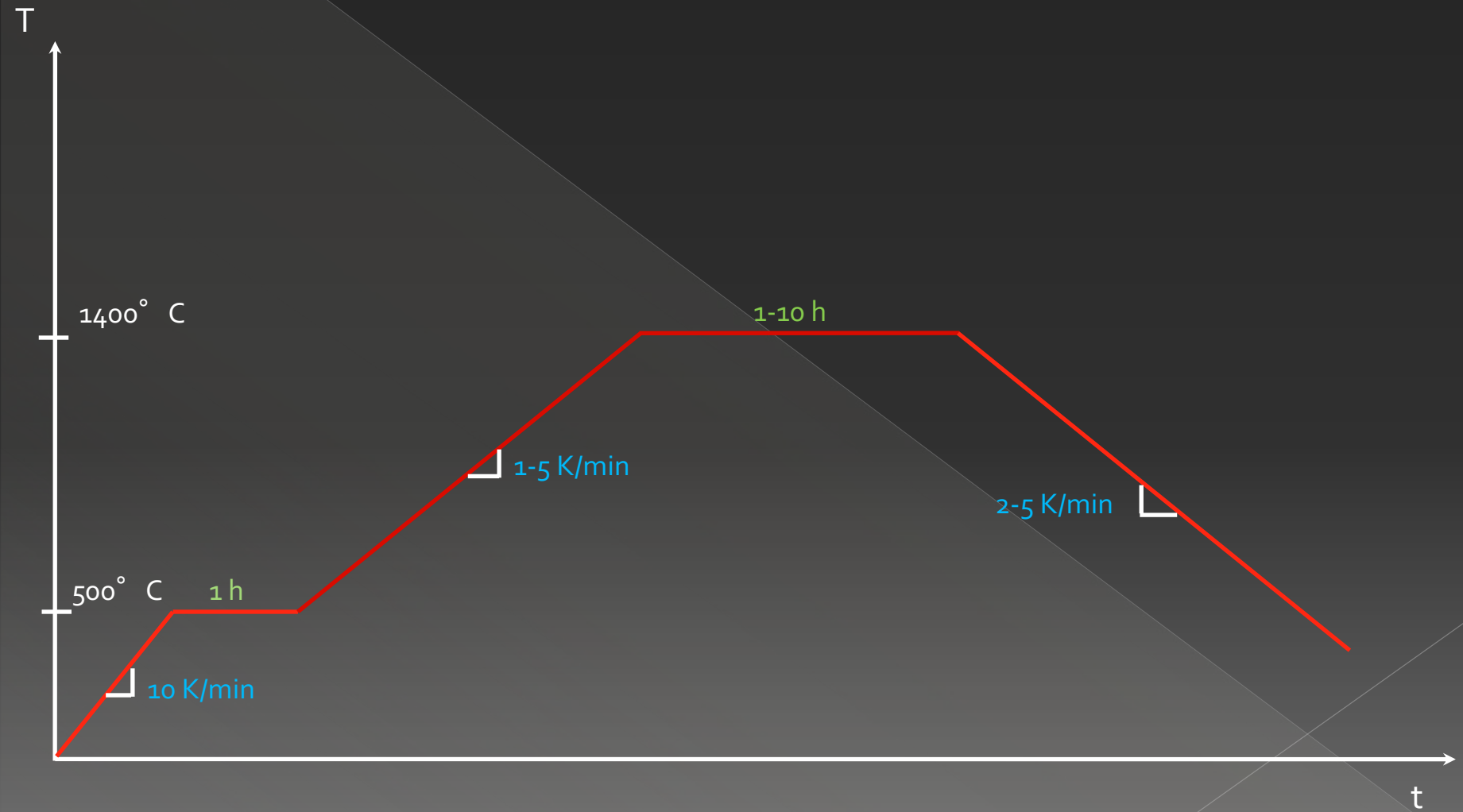
$$\frac{\sqrt{D \cdot t}}{a} \approx 1$$

DENSITY DETERMINATION BY ARCHIMEDE'S PRINCIPLE

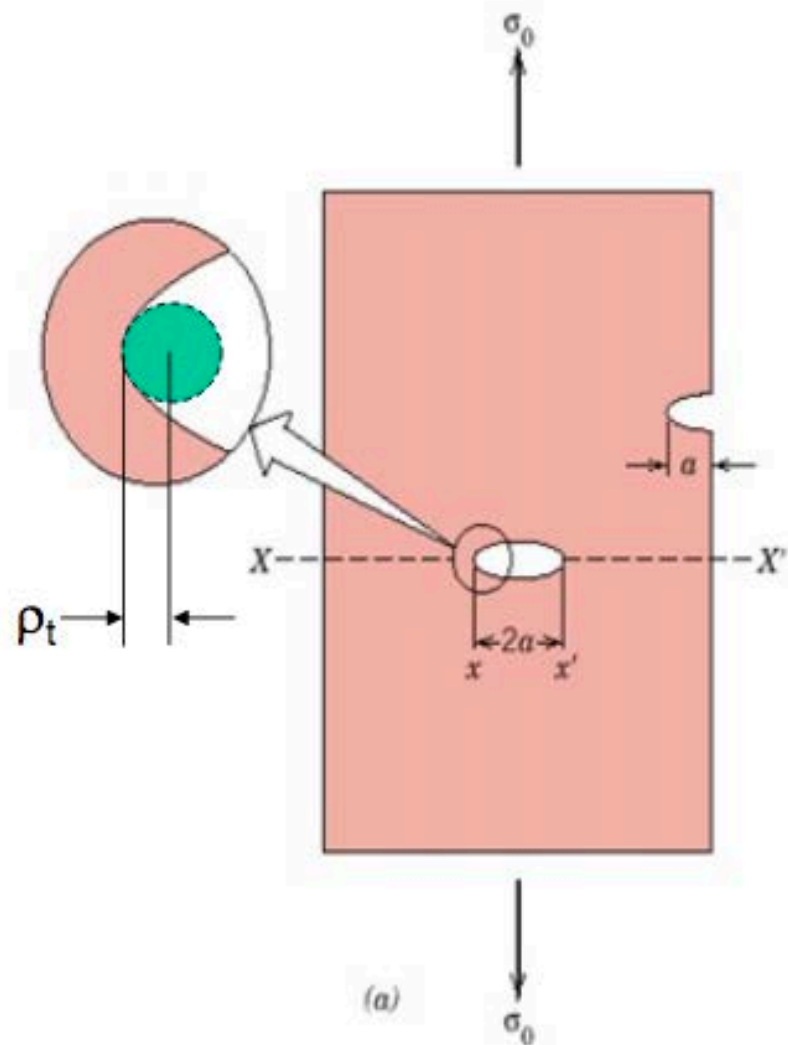
- D = dry weight
- boil the piece for 5 hours
- W = wet weight in air
- S = wet weight in water suspended
- V = external volume of the piece: $V = W - S$
- BULK DENSITY $B = D/V$
- P = apparent porosity $P = (W-D)/V$



TYPICAL SINTERING TIME-TEMPERATURE PROFILE



Flaws are Stress Concentrators



If the crack is similar to an elliptical hole through plate, and is oriented perpendicular to applied stress, the **maximum stress σ_m**

$$\sigma_m = 2\sigma_0 \left(\frac{a}{\rho_t} \right)^{1/2} = K_t \sigma_0$$

where

ρ_t = radius of curvature

σ_0 = applied stress

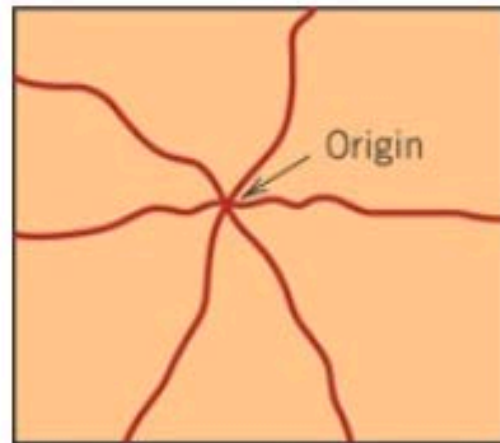
σ_m = stress at crack tip

a = length of surface crack or $\frac{1}{2}$ length of internal crack

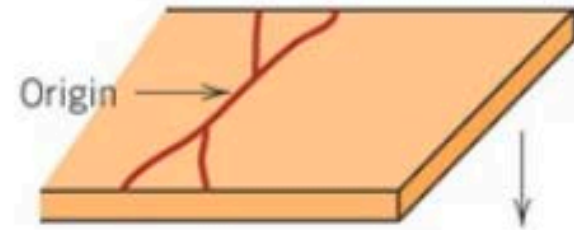
$\sigma_m / \sigma_0 = K_t$ the stress concentration factor

Brittle Fracture of Ceramics

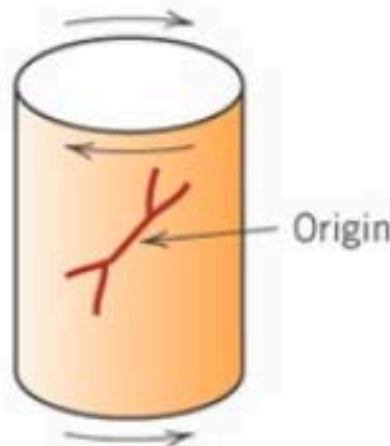
- Most ceramics (at room temperature) fracture before any plastic deformation can occur.
- Typical crack configurations for 4 common loading methods.



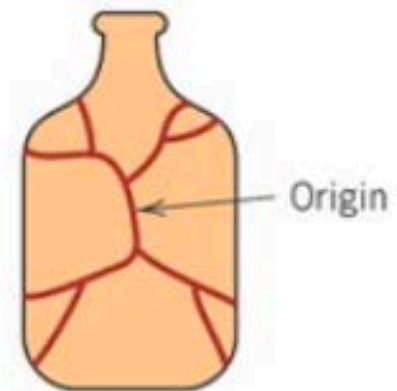
Impact or point loading
(a)



Bending
(b)



Torsion
(c)



Internal pressure
(d)

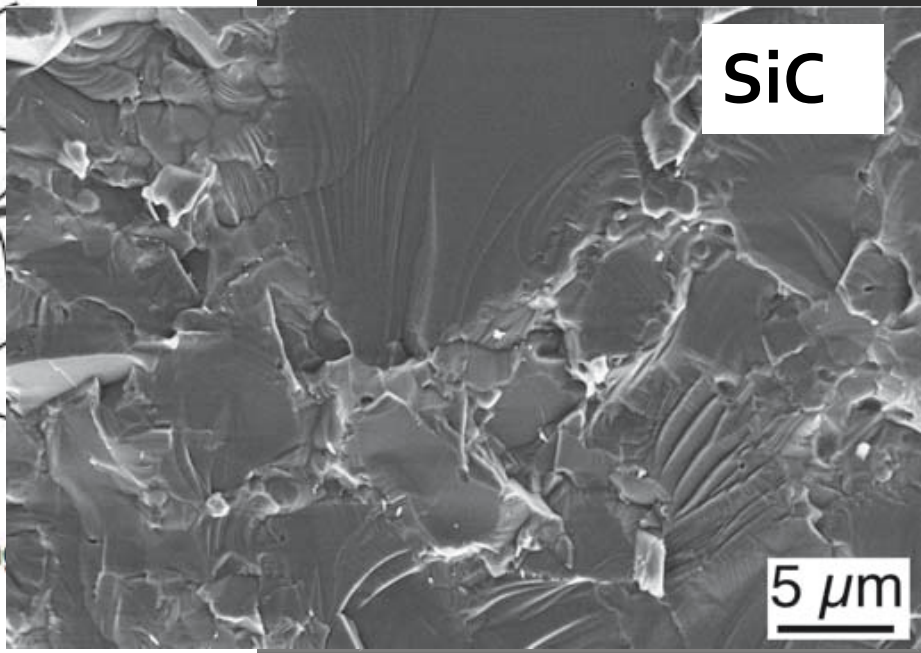
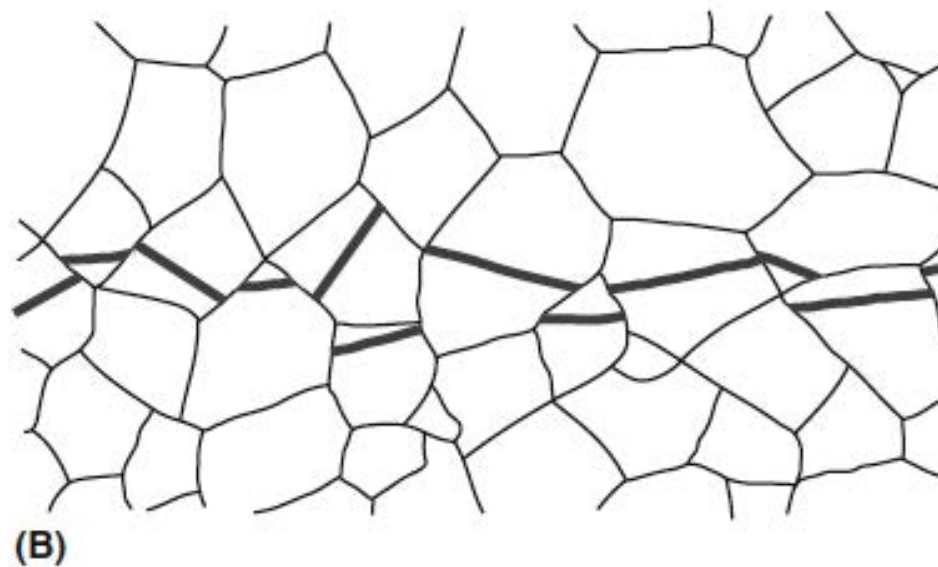
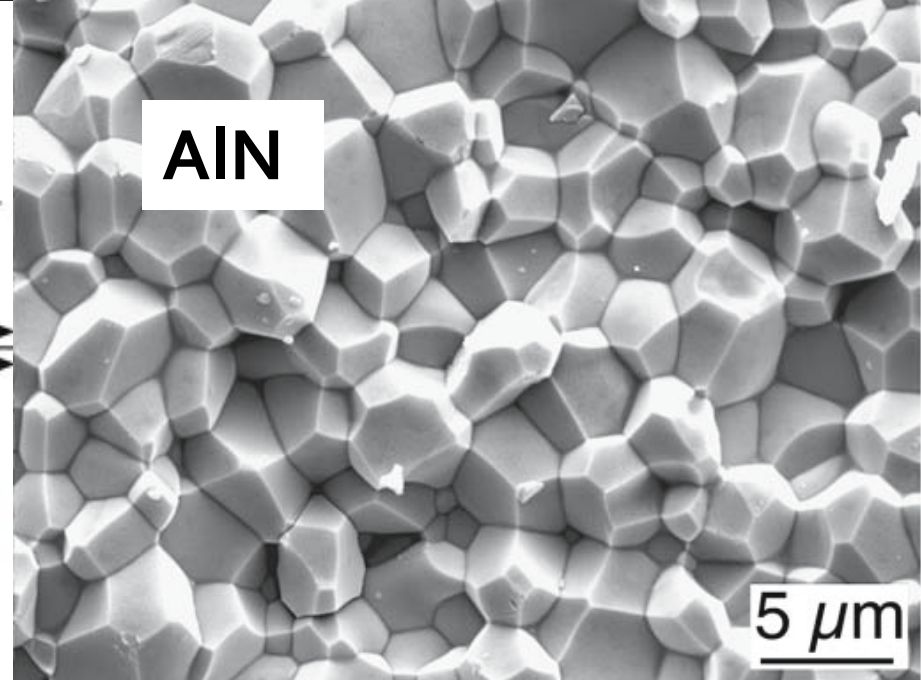
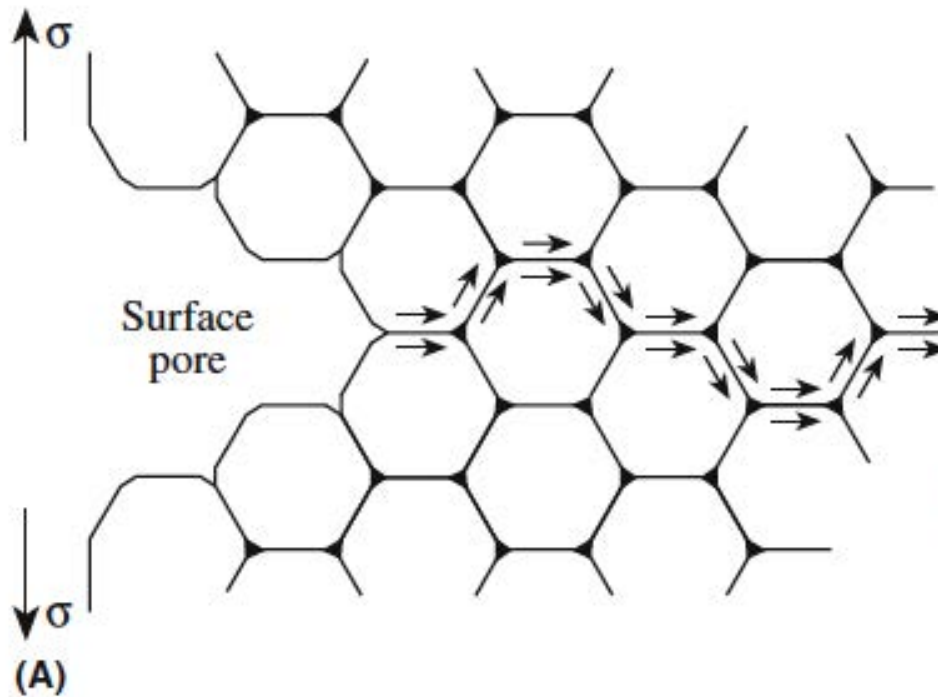
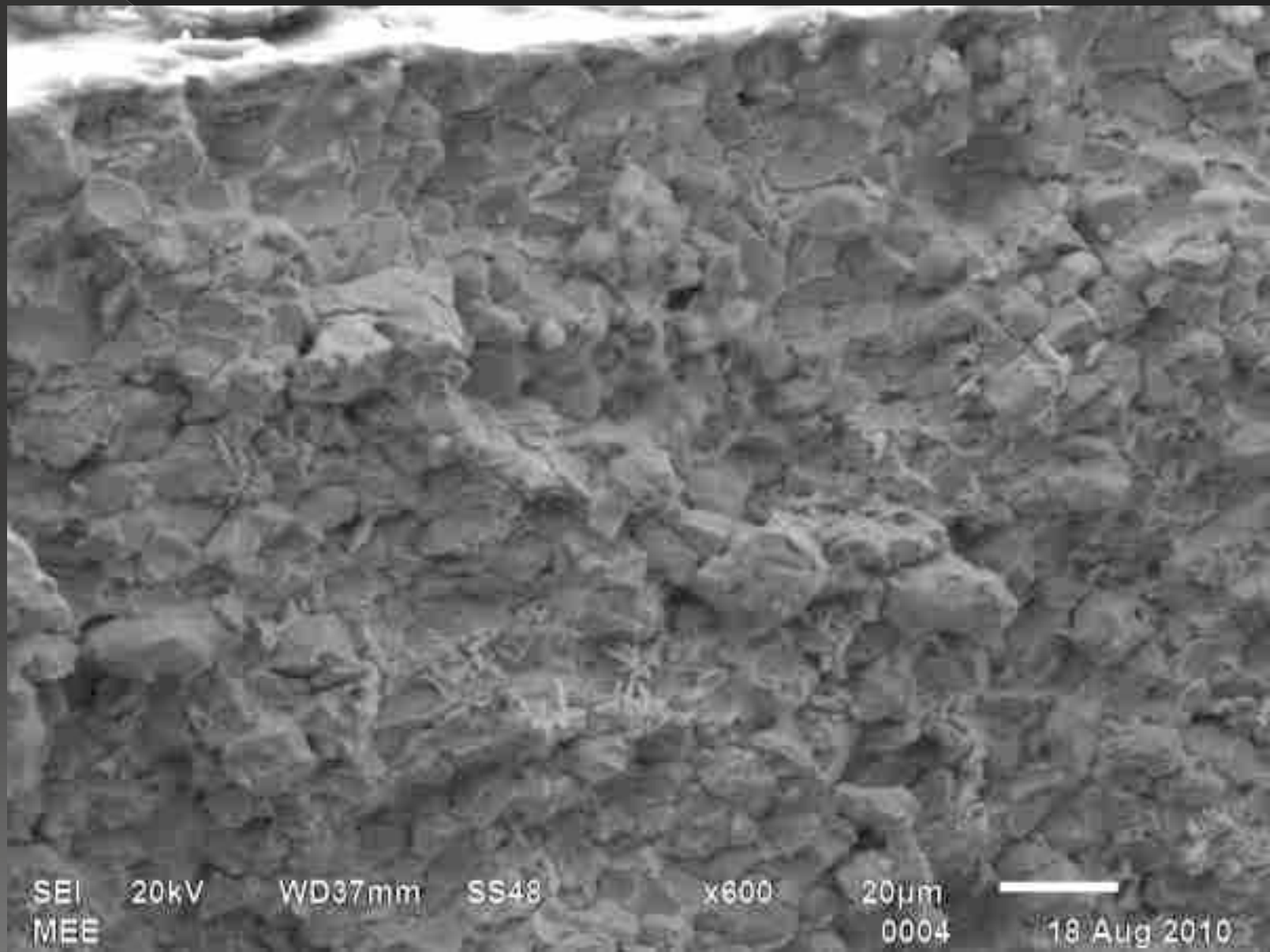


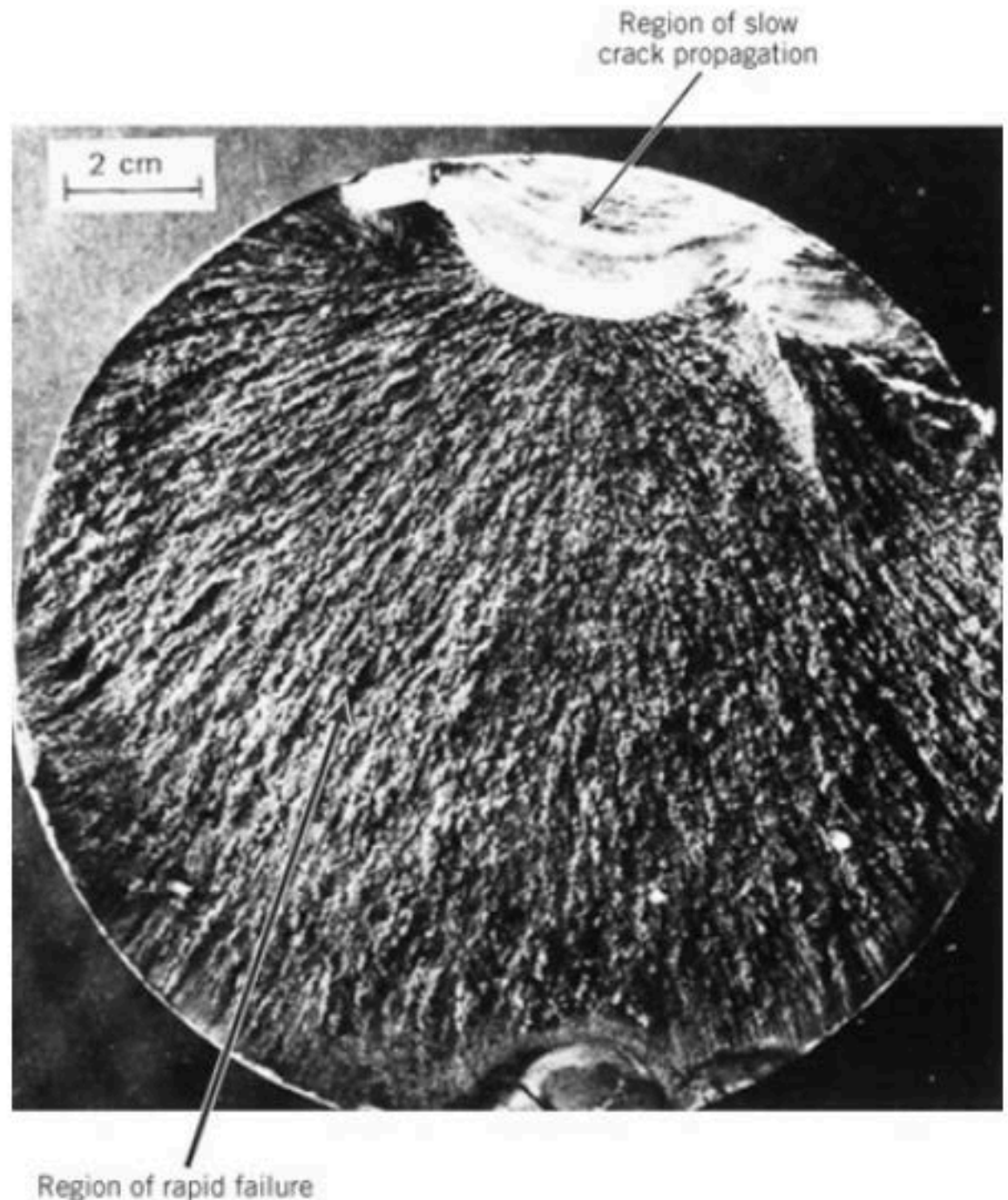
FIGURE 18.12 (a) Illustration of intergranular cracking. Illustration of transgranular cracking.

Undistinct features: brittle fracture (SiC)



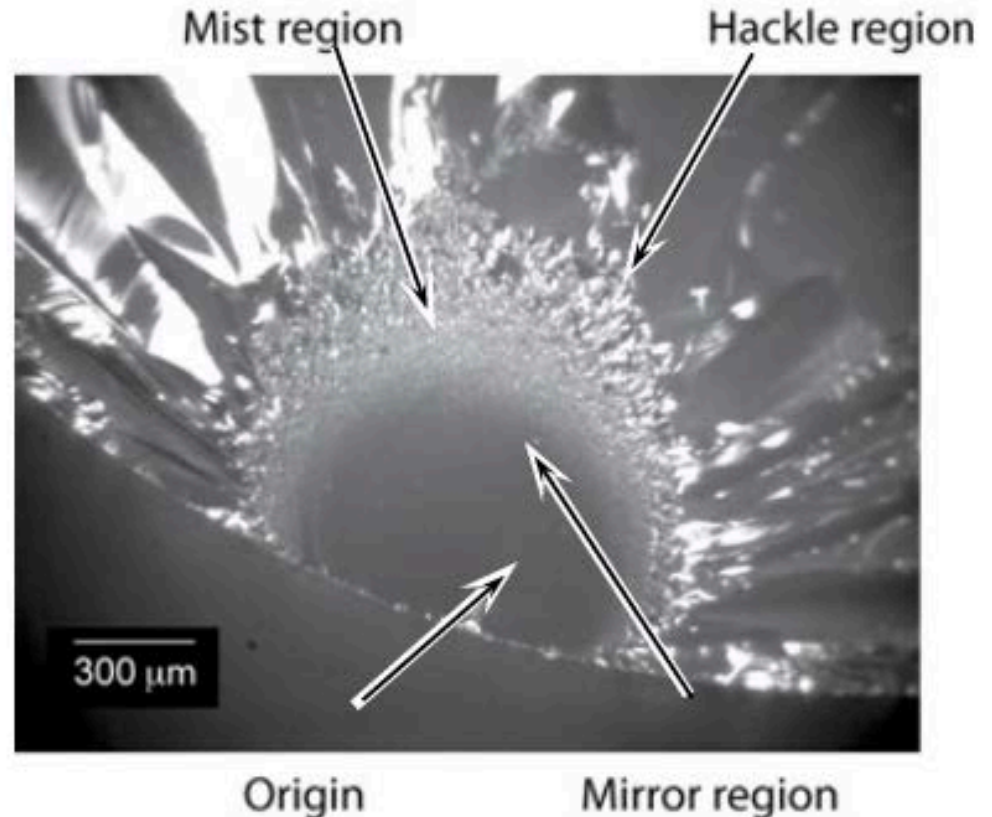
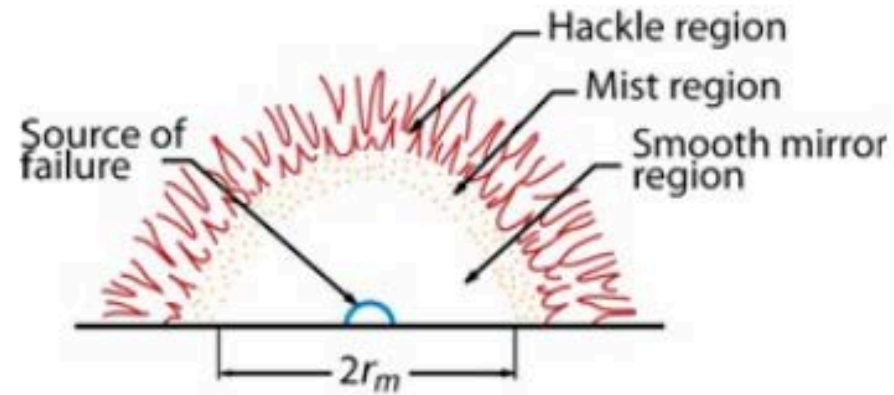
Fatigue

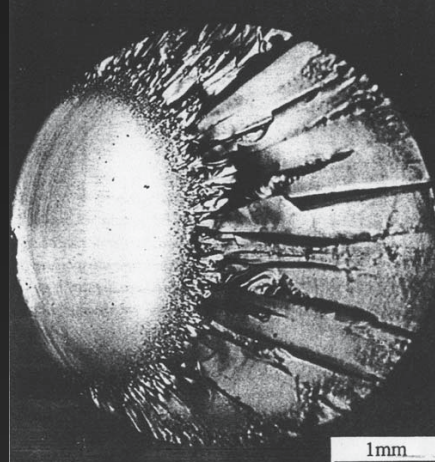
- Fracture surface with crack initiation at top. Surface shows predominantly dull fibrous texture where rapid failure occurred after crack achieved critical size.
- Fatigue failure
 1. Crack initiation
 2. Crack propagation
 3. Final failure



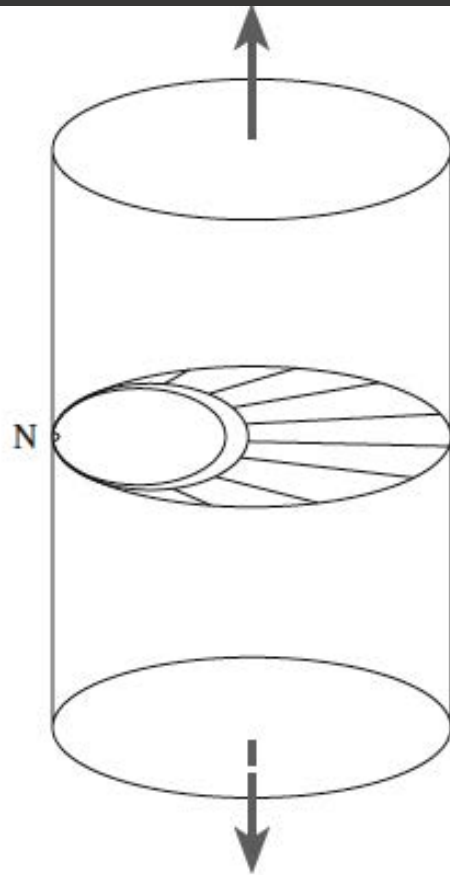
Brittle Fracture of Ceramics

- Surface of a 6-mm diameter fused silica rod.
- Characteristic fracture behavior in ceramics
 - Origin point
 - Initial region (**mirror**) is flat and smooth
 - After reaches critical velocity crack branches
 - **mist**
 - **hackle**

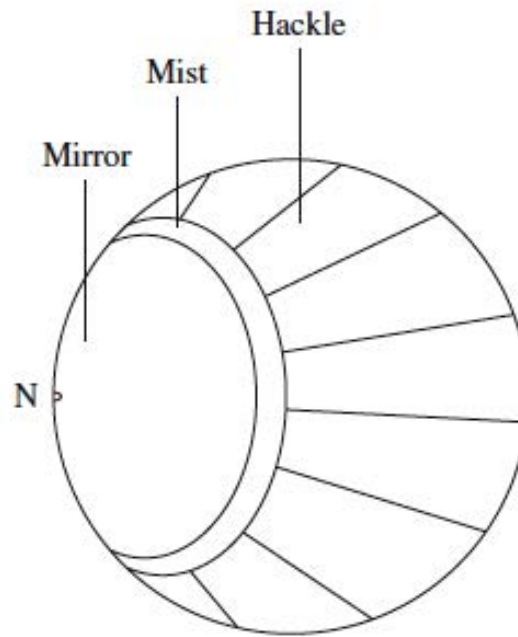




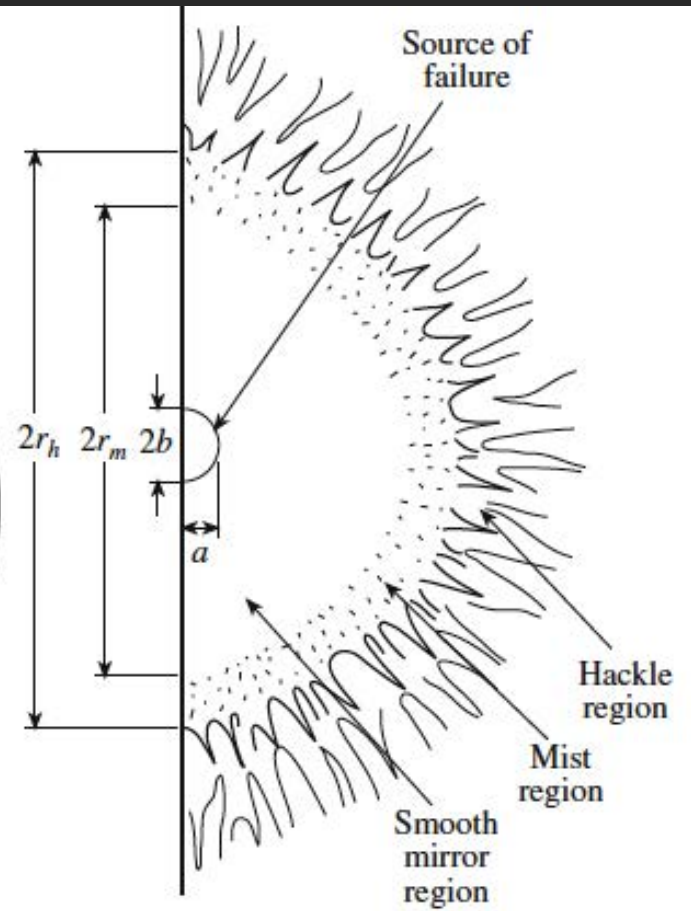
1mm



(B)

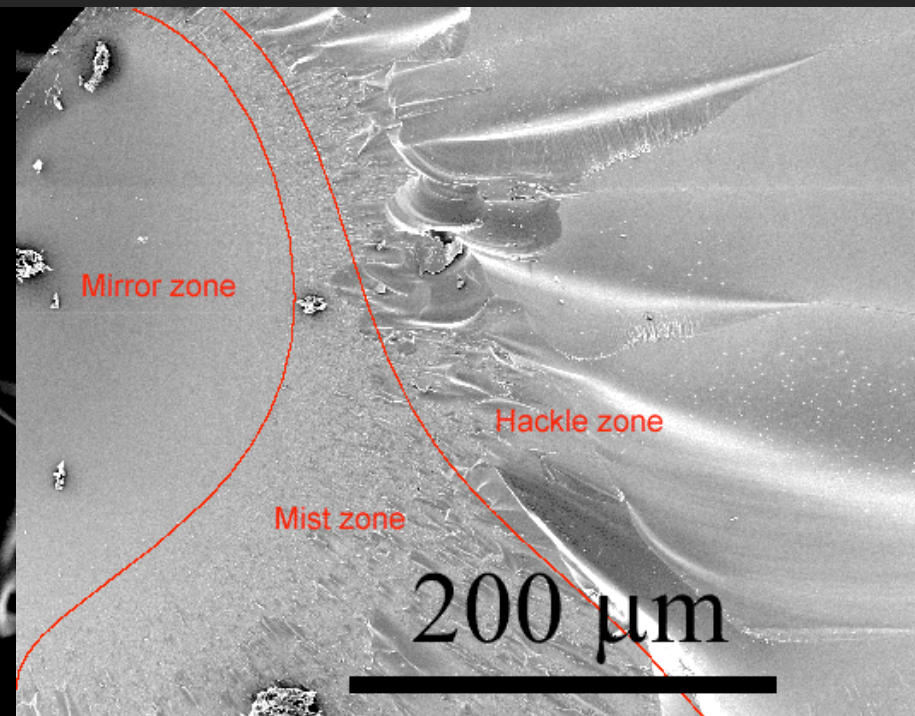
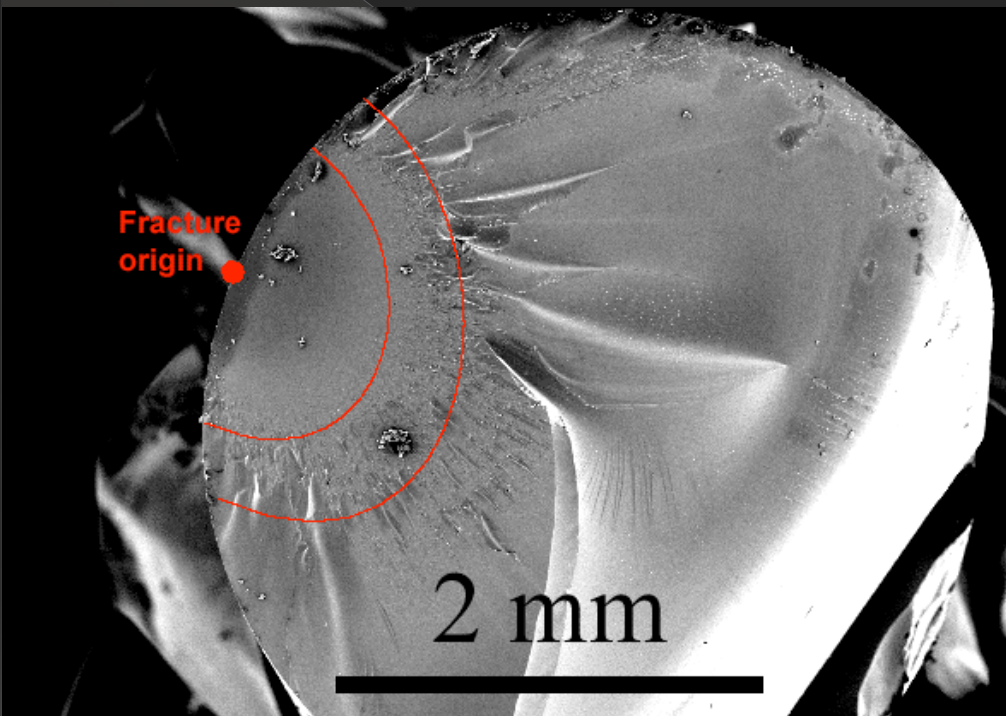


(C)

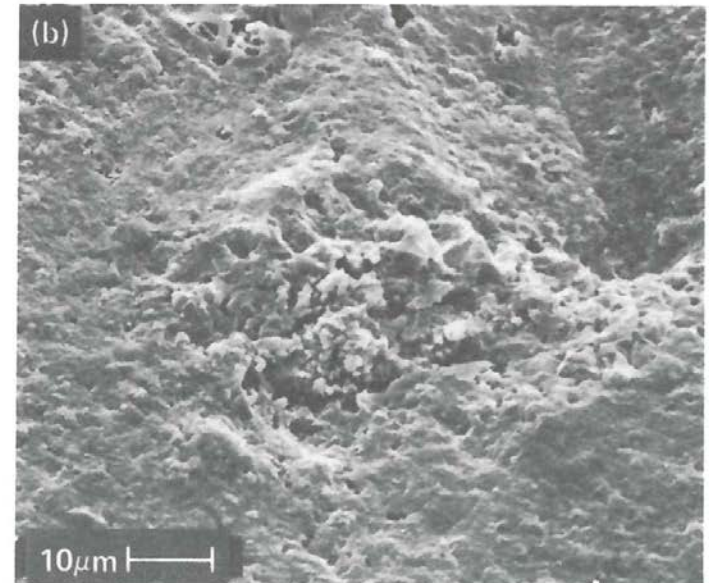
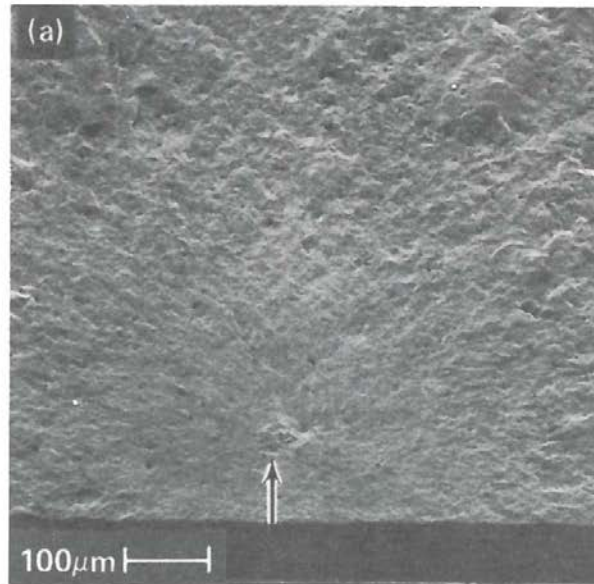
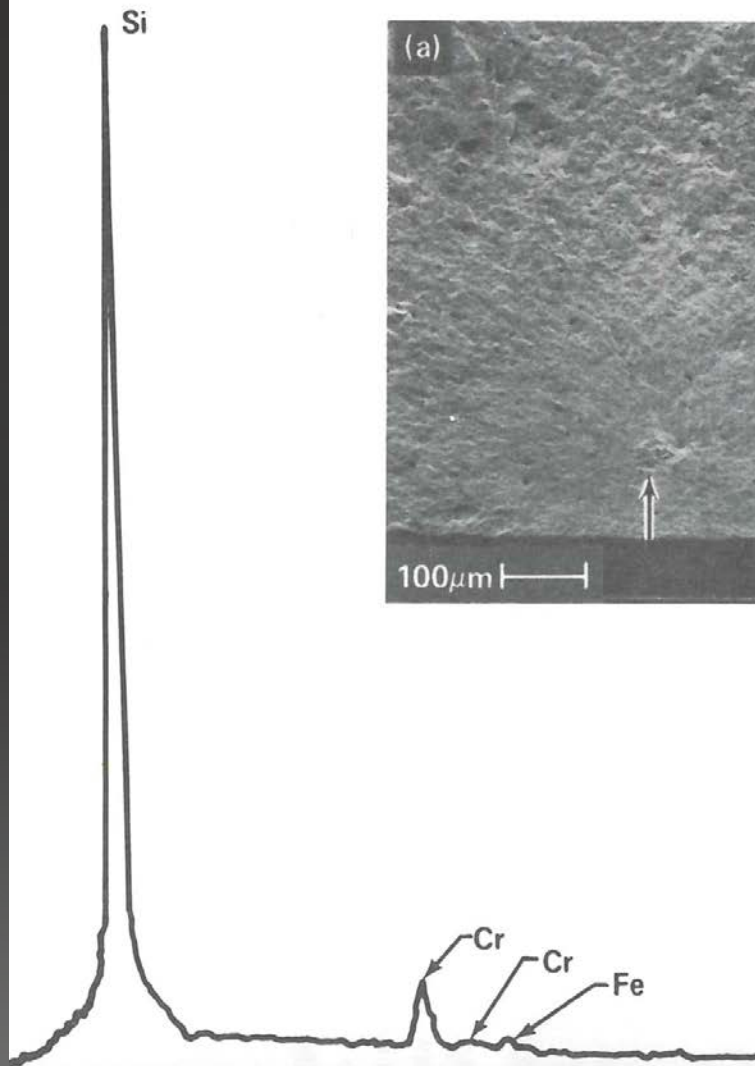


(D)

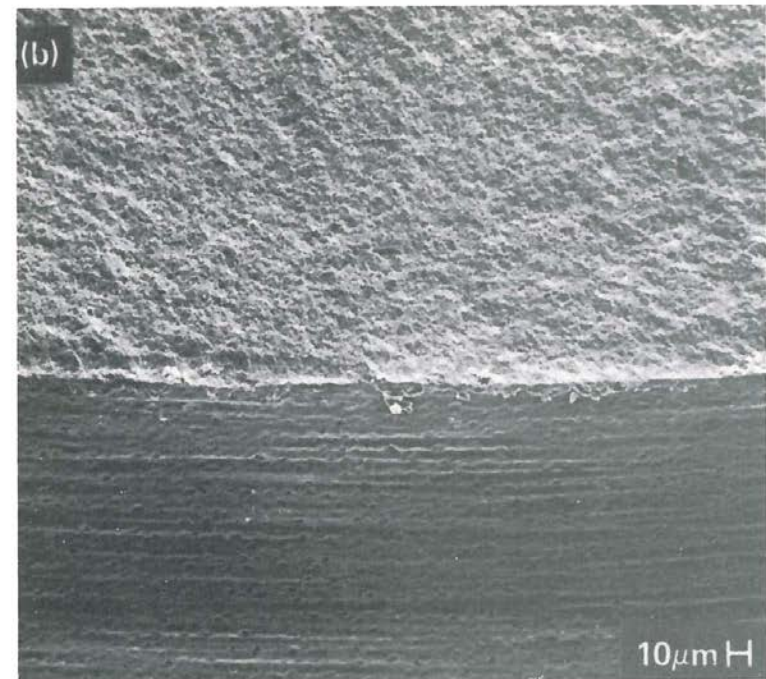
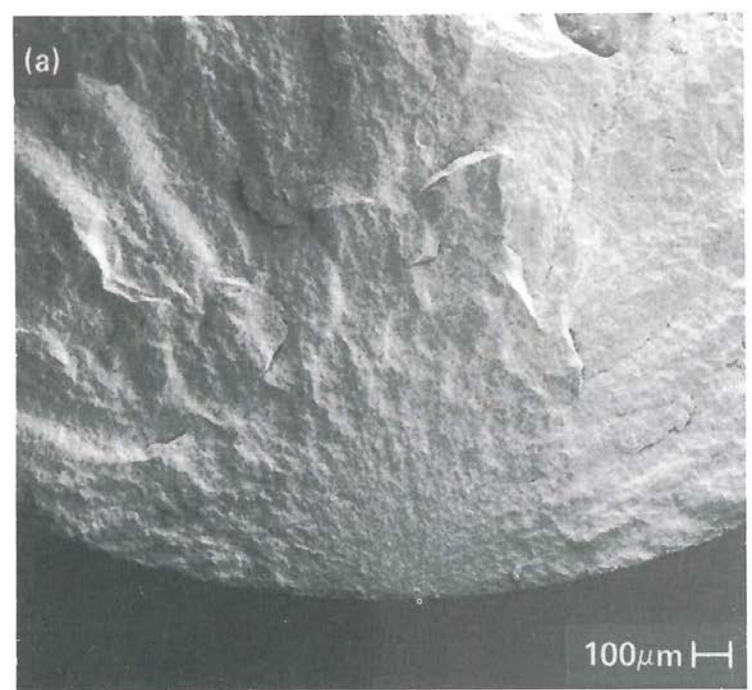
Fracture of glass



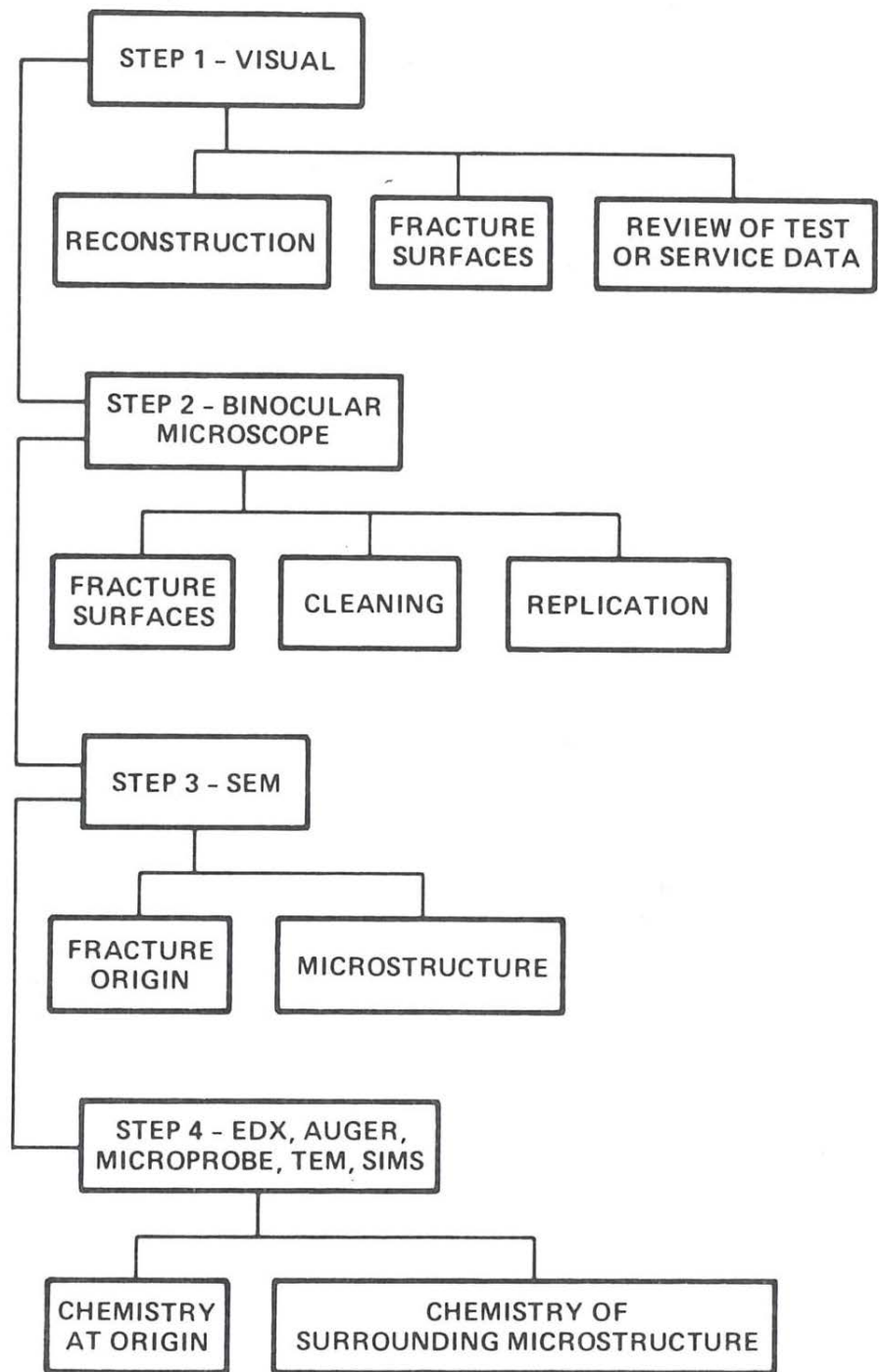
Fracture surface of silicon nitride with steel impurity



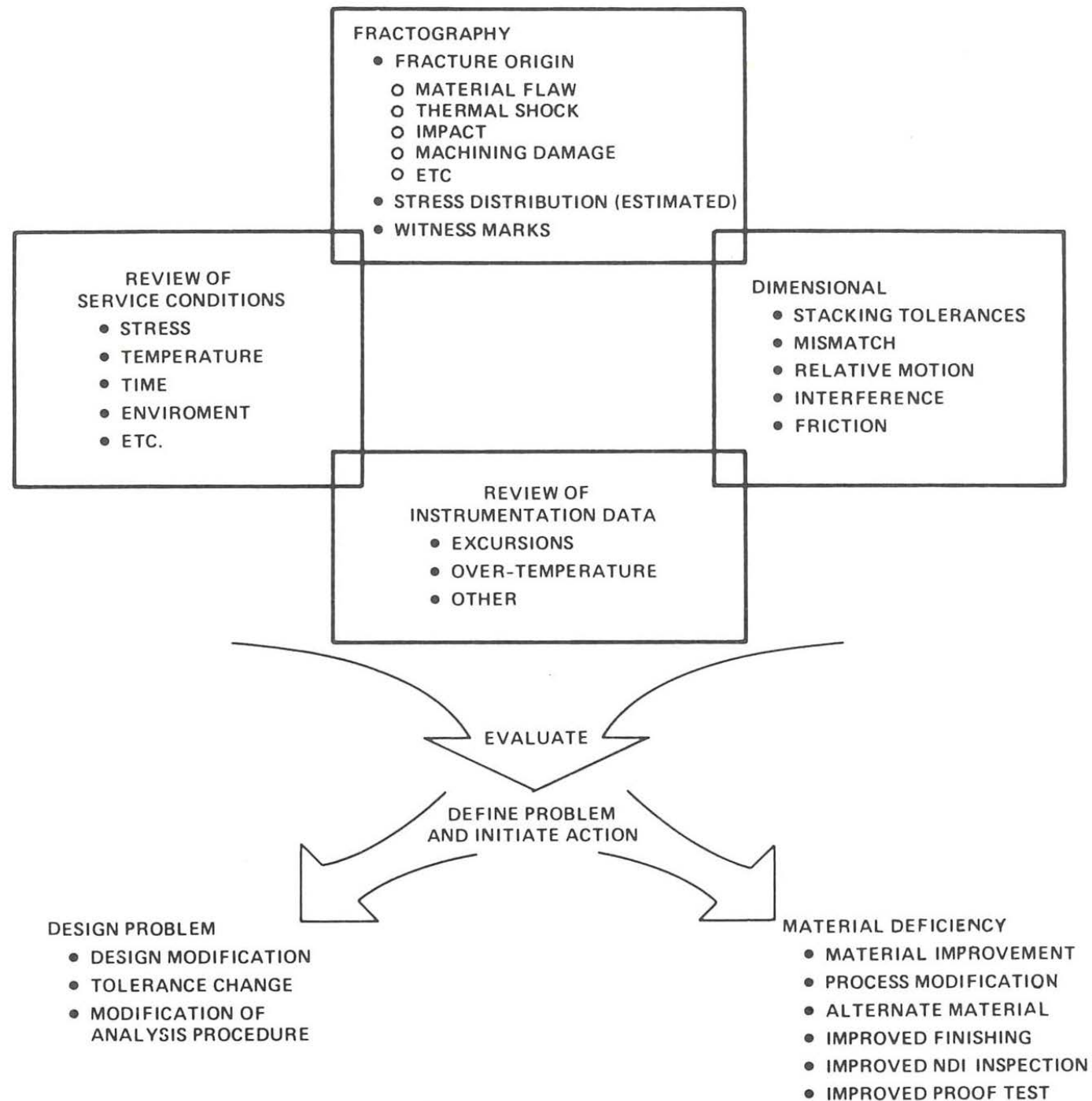
Fracture surface of lathe machined Silicon nitride



Roadmap for fractography



Roadmap for correcting failure



Toughening by whiskers and fibers

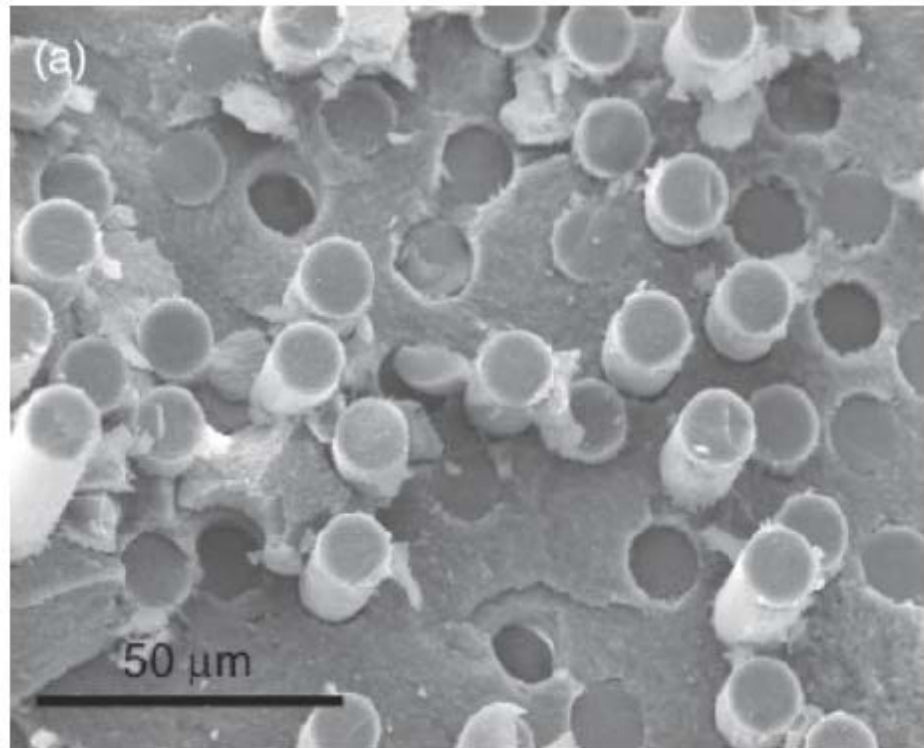
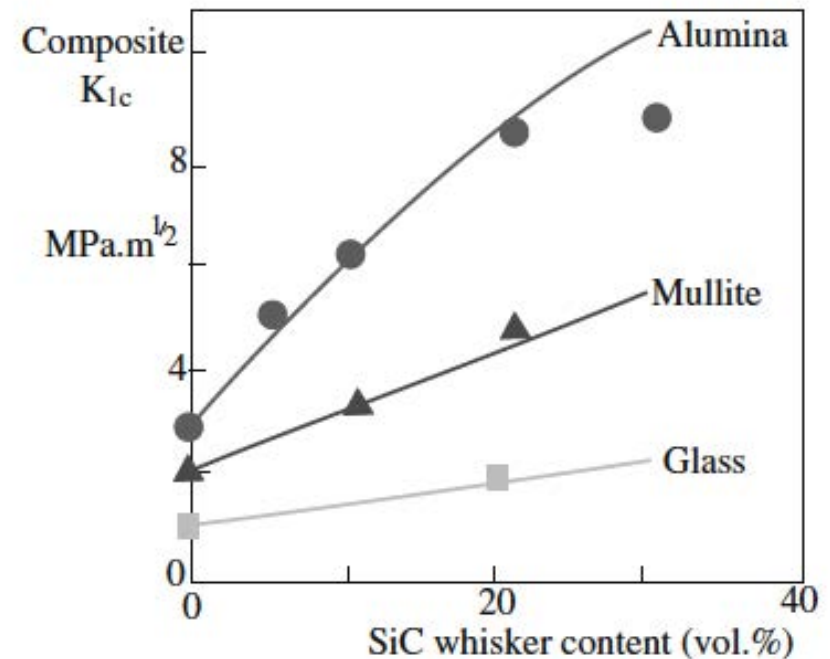


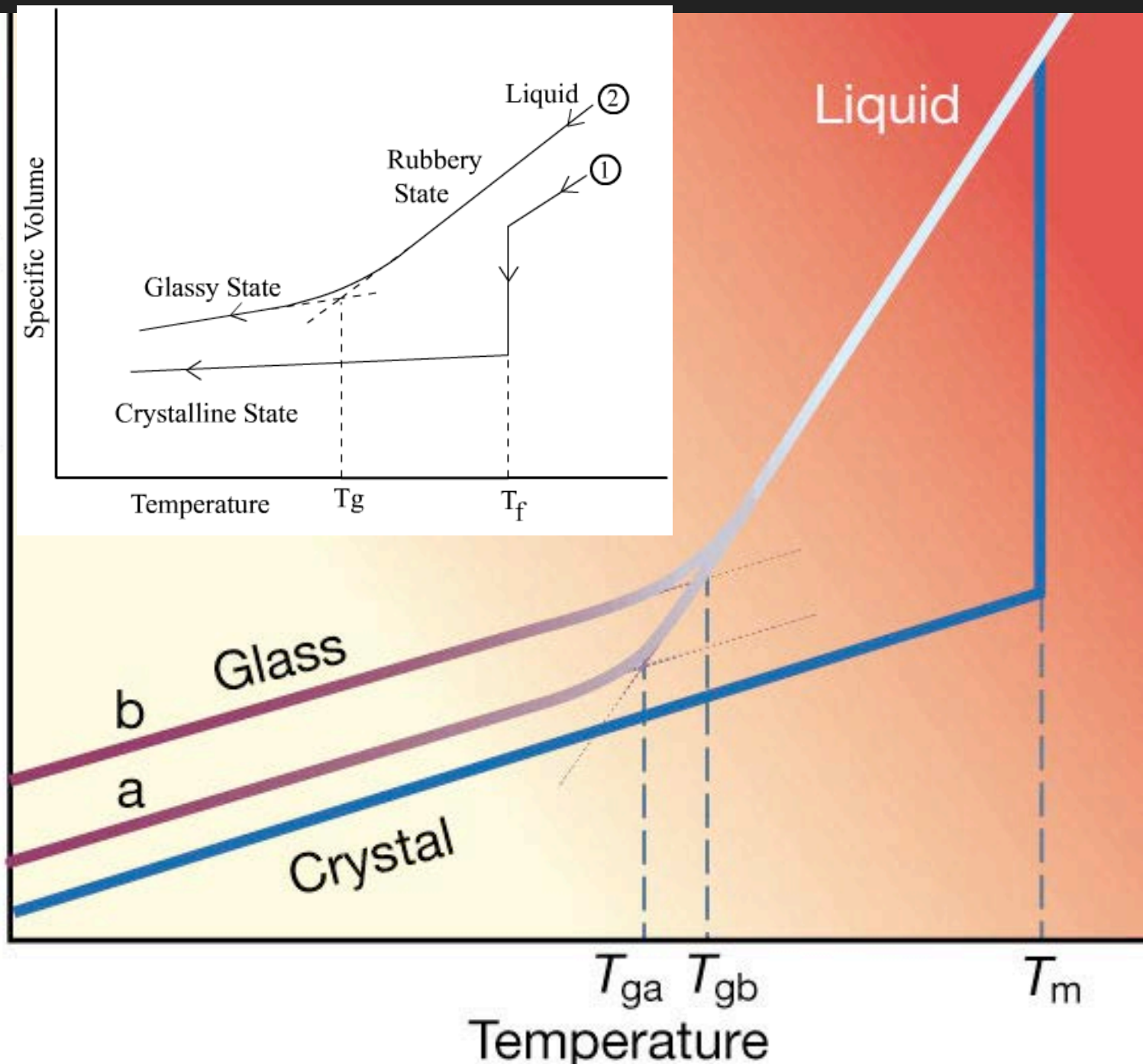
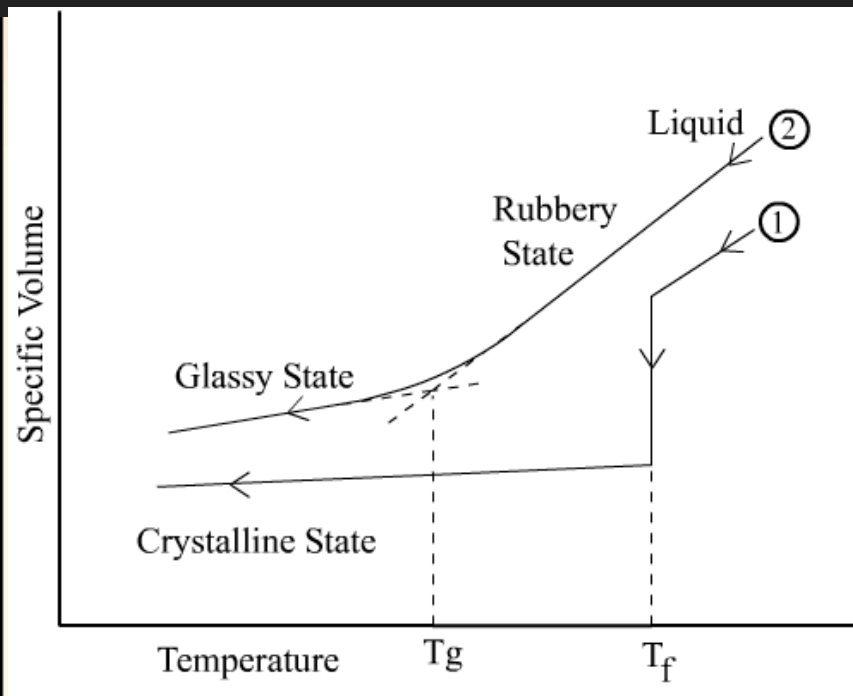
FIGURE 18.18 SEM image showing fiber pullout on the fracture surface of AlPO_4 -coated alumina/mullite fiber/ Al_2O_3 CMC, hot pressed at 1250°C for 1 h.



Glass theory

- Glasses lack the periodic (long range) order of a crystal
- •
- Infinite unit cell (no repeating large scale structures)
- •
- 3D network lacking symmetry and periodicity
- •
- ISOTROPIC: same average packing and properties in all directions
- •
- Crystals in different directions(see above):
- •
- different atom packing and so different properties

Volume, Enthalpy



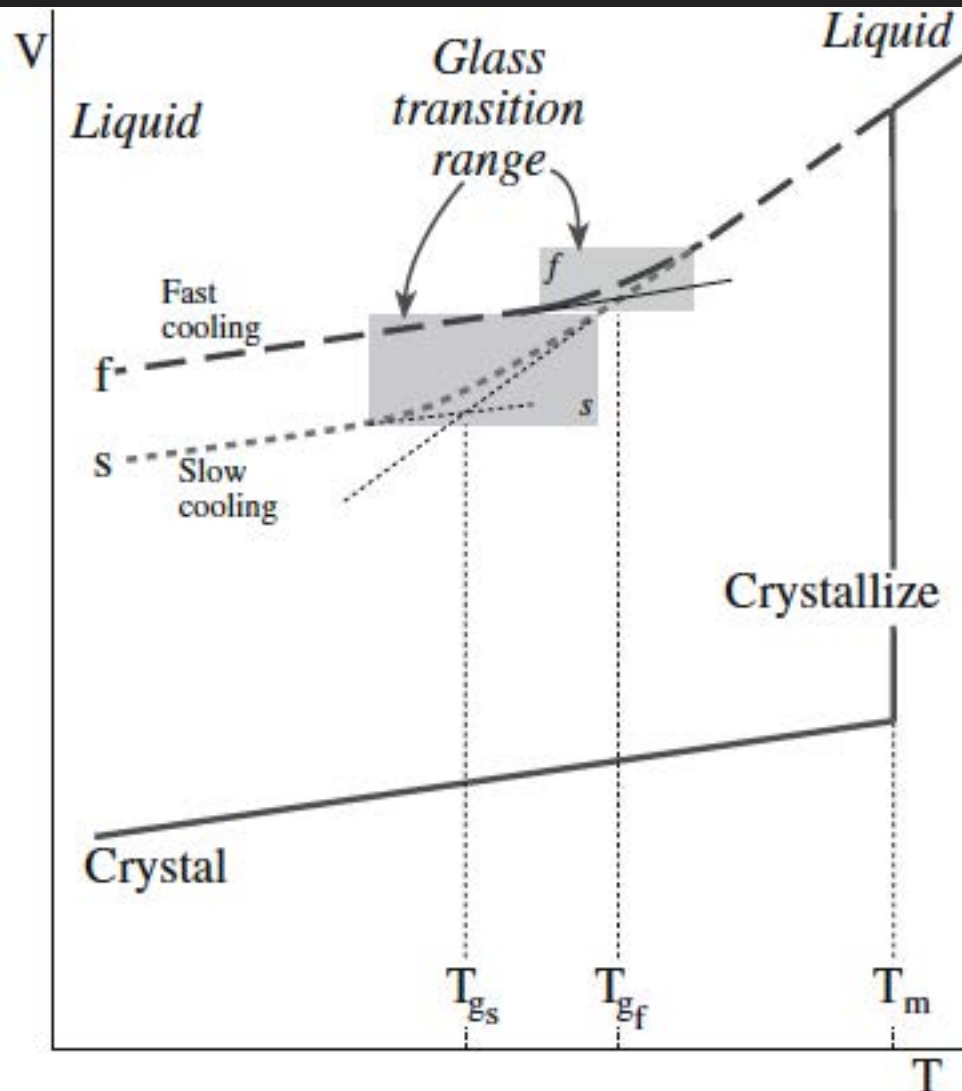
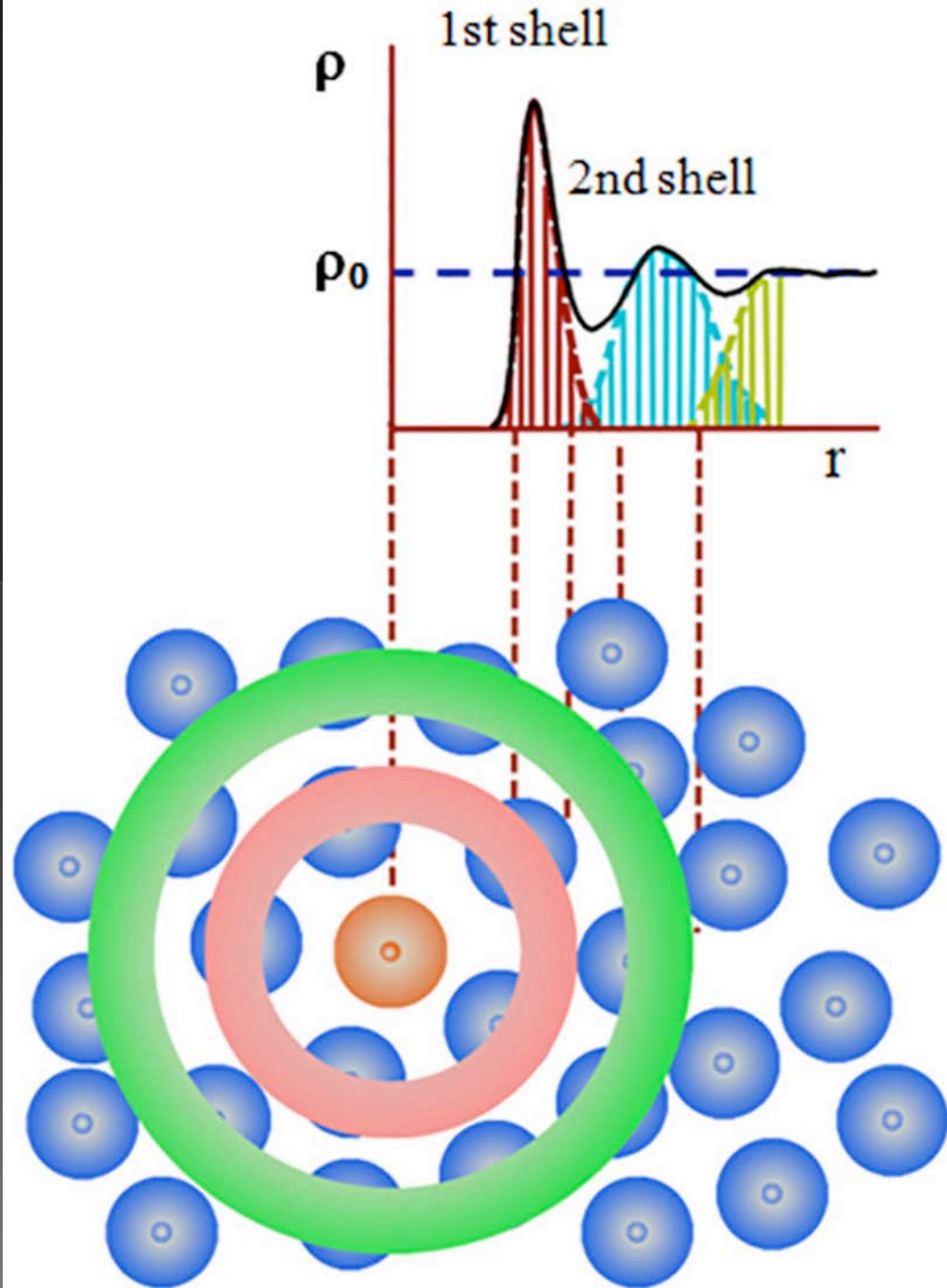
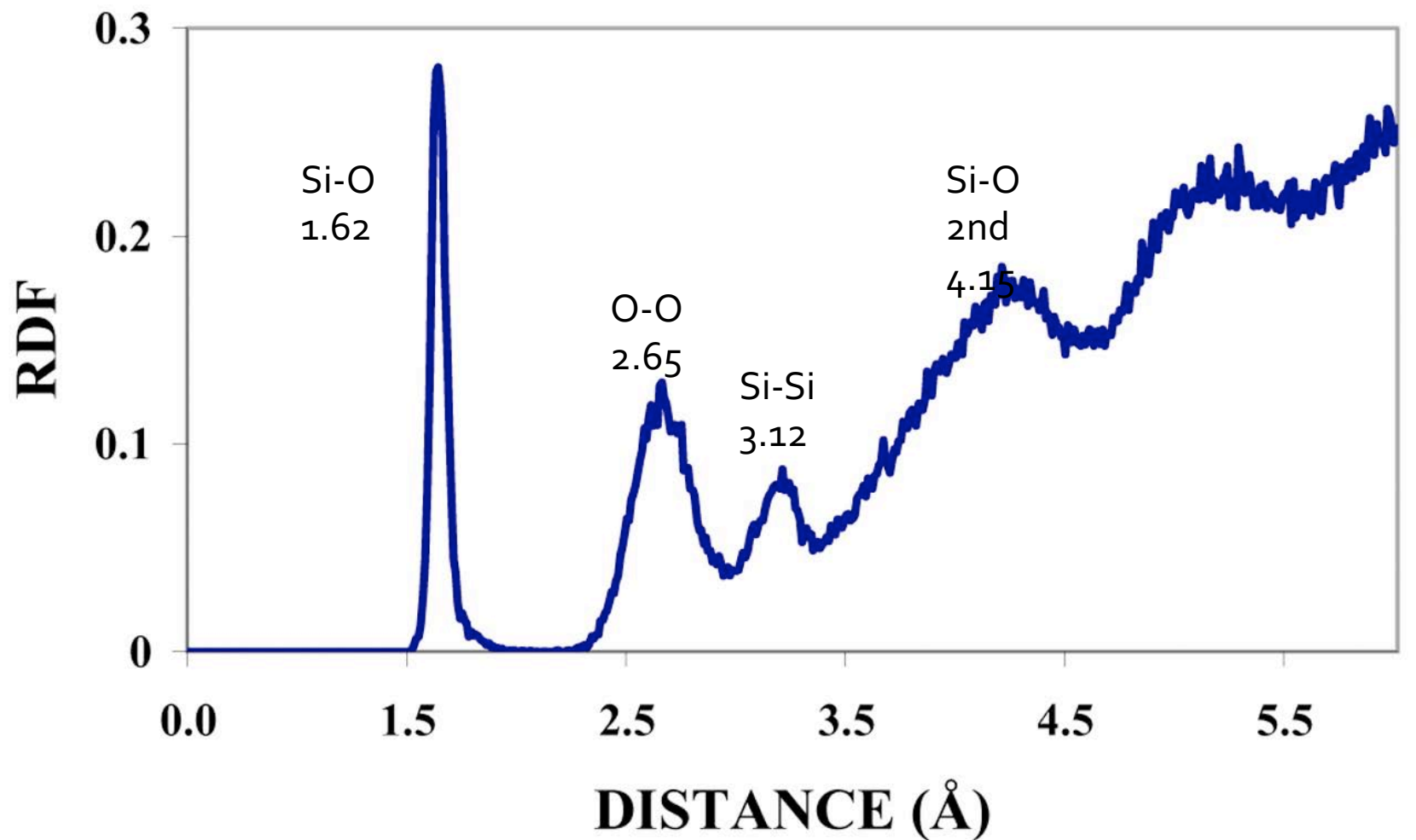


FIGURE 21.1 Plot of volume versus temperature for a liquid that forms a glass on cooling and one that forms a crystalline solid. The glass transition temperature, T_g , depends on the cooling rate and is not fixed like T_m .

Pair distribution
function of SiO₂ glass



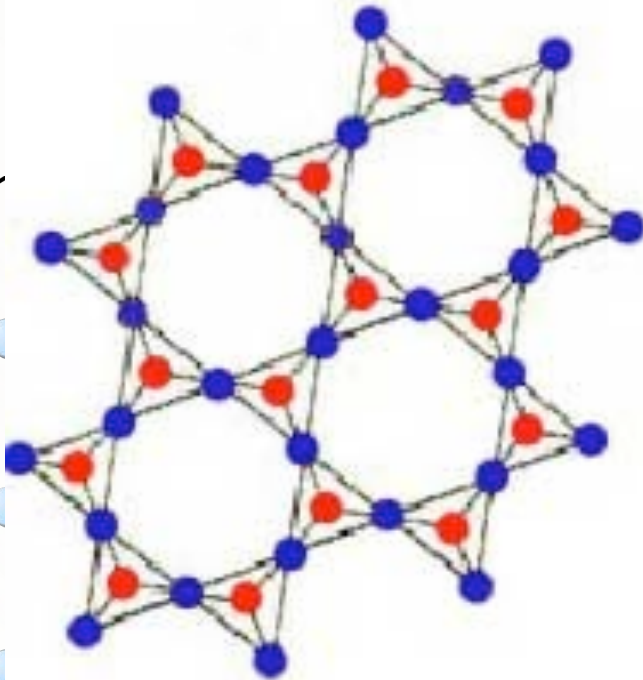
Radial distribution function for SiO_2



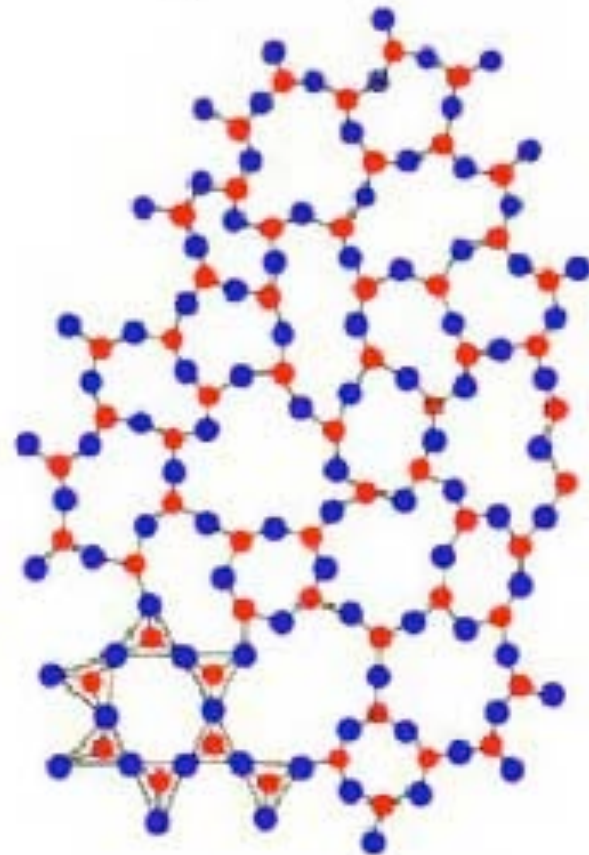
Glass structure:

SiO₂ quartz compared to SiO₂ glass

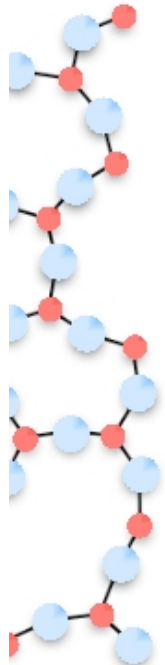
Crystalline SiO₂
(Quartz)



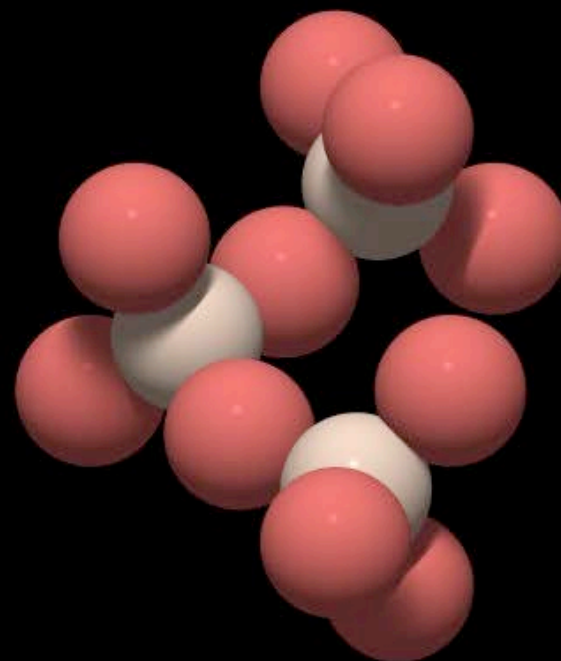
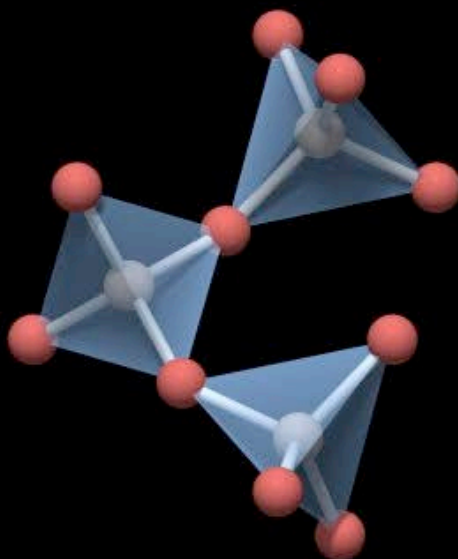
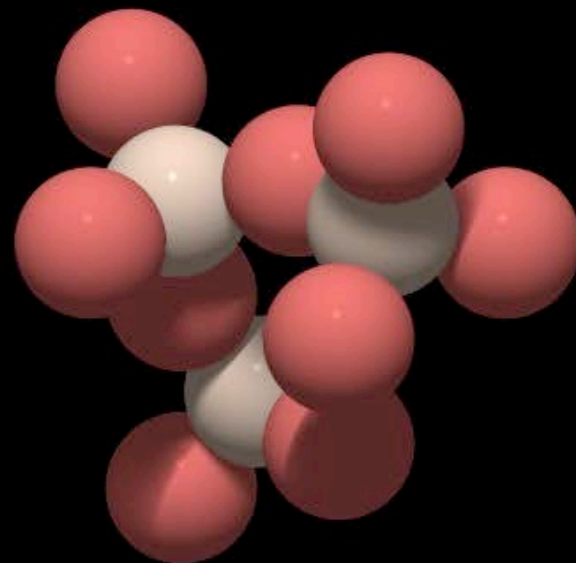
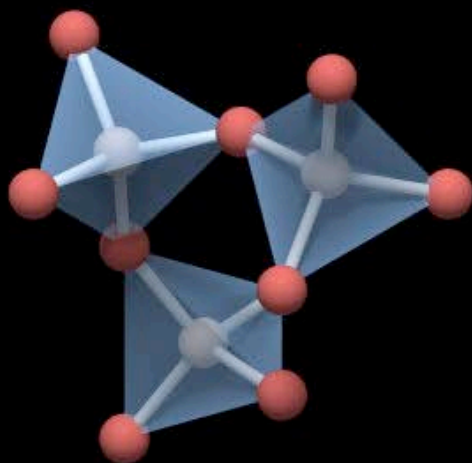
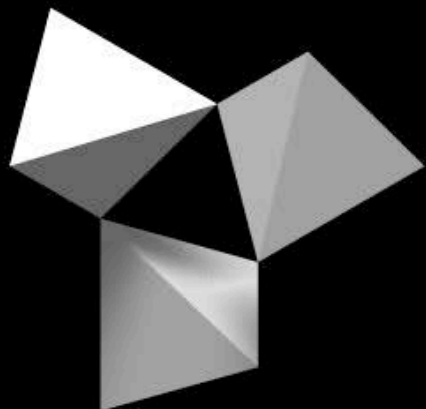
Amorphous SiO₂
(Glass)



● Si ● O



● O
● Si

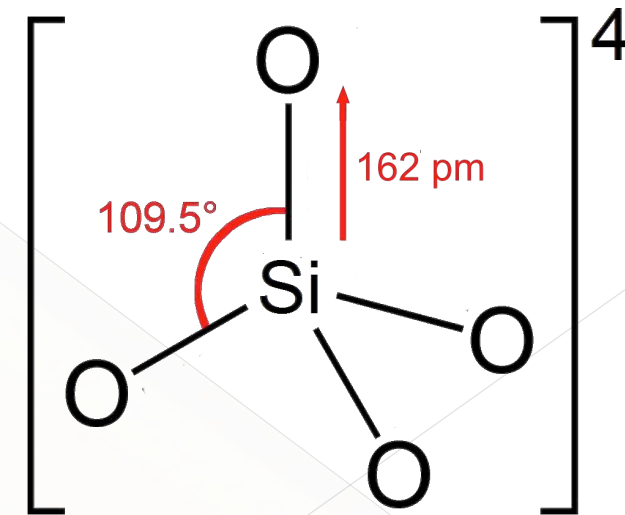


Zachariasen rules for glass A_mO_n

- 1) An oxygen atom is linked to no more than two glass-forming atoms A.
- 2) The number of oxygen atoms around each glass-forming atom A is small, perhaps 3 or 4.
- 3) Among the oxygen-containing polyhedra, a polyhedron cation A shares corners, but no sides or faces.
- 4) For three-dimensional networks of oxygen-containing polyhedra, at least three corners must be shared.

In general, all four rules should be satisfied for glass formation to occur.

Low coordination numbers, corner-sharing rules imply that glass formation is more likely with open, low density polyhedral structures.



1. Consider Silica:

- covalent Si-O bond: sp^3 hybrid
 - tetrahedral bonding
- Pauling's packing rule:

$$\frac{r(\text{Si}^{4+})}{r(\text{O}^{2-})} = \frac{0.40}{1.40} \approx 0.29 \quad \text{prefers tetrahedral bonding}$$

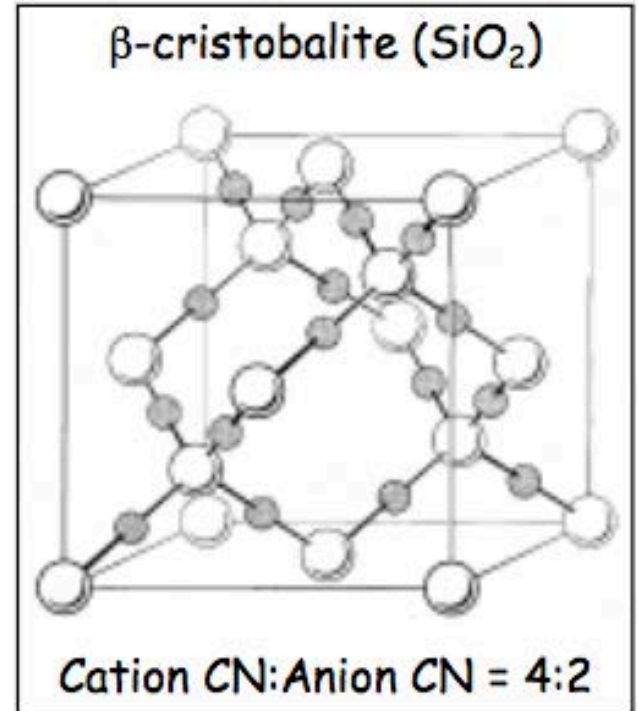
- satisfies Zachariasen's rule #2.

$$\frac{\text{charge}(\text{Si}^{4+})}{\text{CN}(\text{Si}^{4+})} = \frac{4}{4} = \frac{\text{charge}(\text{O}^{2-})}{\text{CN}(\text{O}^{2-})} = \frac{2}{2} \quad \text{CN}(\text{O}^{2-}) \text{ is } 2.$$

- satisfies Zachariasen's rule #1.

Crystal structure: sharing four corners:

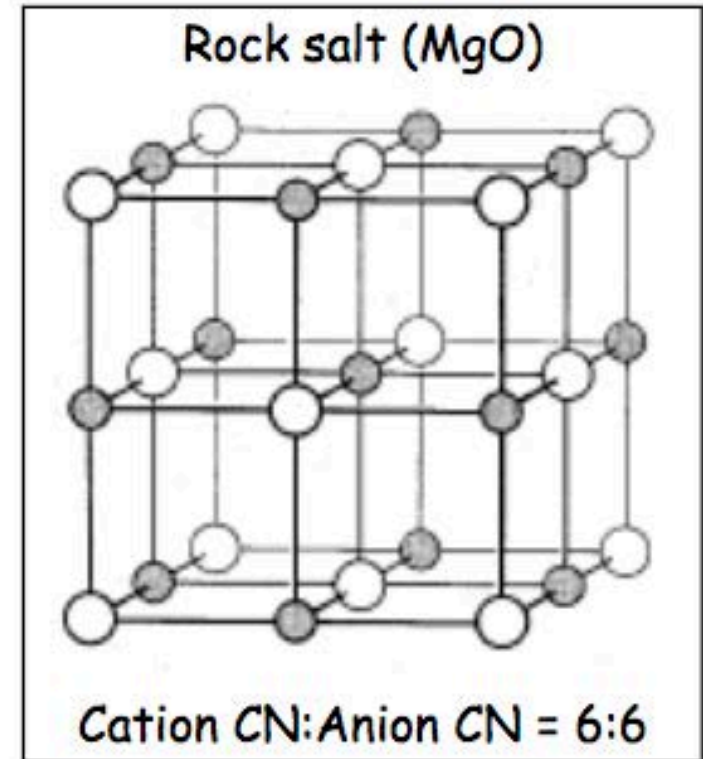
All Rules are Satisfied: SiO_2 forms a glass.



2. Consider Magnesia (MgO):

- ionic Mg-O bond
 - Pauling's packing rule:
$$\frac{r(\text{Mg}^{2+})}{r(\text{O}^{2-})} = \frac{0.72}{1.40} \approx 0.51 \quad \text{prefers octahedral bonding}$$
 - violates Zachariasen's rule #2.
$$\frac{\text{charge}(\text{Mg}^{2+})}{\text{CN}(\text{Mg}^{2+})} = \frac{2}{6} = \frac{\text{charge}(\text{O}^{2-})}{\text{CN}(\text{O}^{2-})} = \frac{2}{6} \quad \text{CN}(\text{O}^{2-}) \text{ is } 6.$$
 - violates Zachariasen's rule #1.

Crystal structure: edge-sharing polyhedra;
Rules are Not Satisfied: MgO does not form a glass.



3. Consider Alumina (Al_2O_3):

- Pauling's packing rule:

$$\frac{r(\text{Al}^{3+})}{r(\text{O}^{2-})} = \frac{0.53}{1.40} \approx 0.38 \quad \text{octahedral / tetrahedral boundary}$$

- octahedral CN preferred in Al_2O_3 .

$$\frac{\text{charge}(\text{Al}^{3+})}{\text{CN}(\text{Al}^{3+})} = \frac{3}{6} = \frac{\text{charge}(\text{O}^{2-})}{\text{CN}(\text{O}^{2-})} = \frac{2}{4} \quad \text{CN}(\text{O}^{2-}) \text{ is } 4.$$

- violates Zachariasen's rule #1.

Al_2O_3 does not form a glass.

Elements for glass formation

Formers

- B
- Si
- Ge
- Al
- V
- As

Modifiers

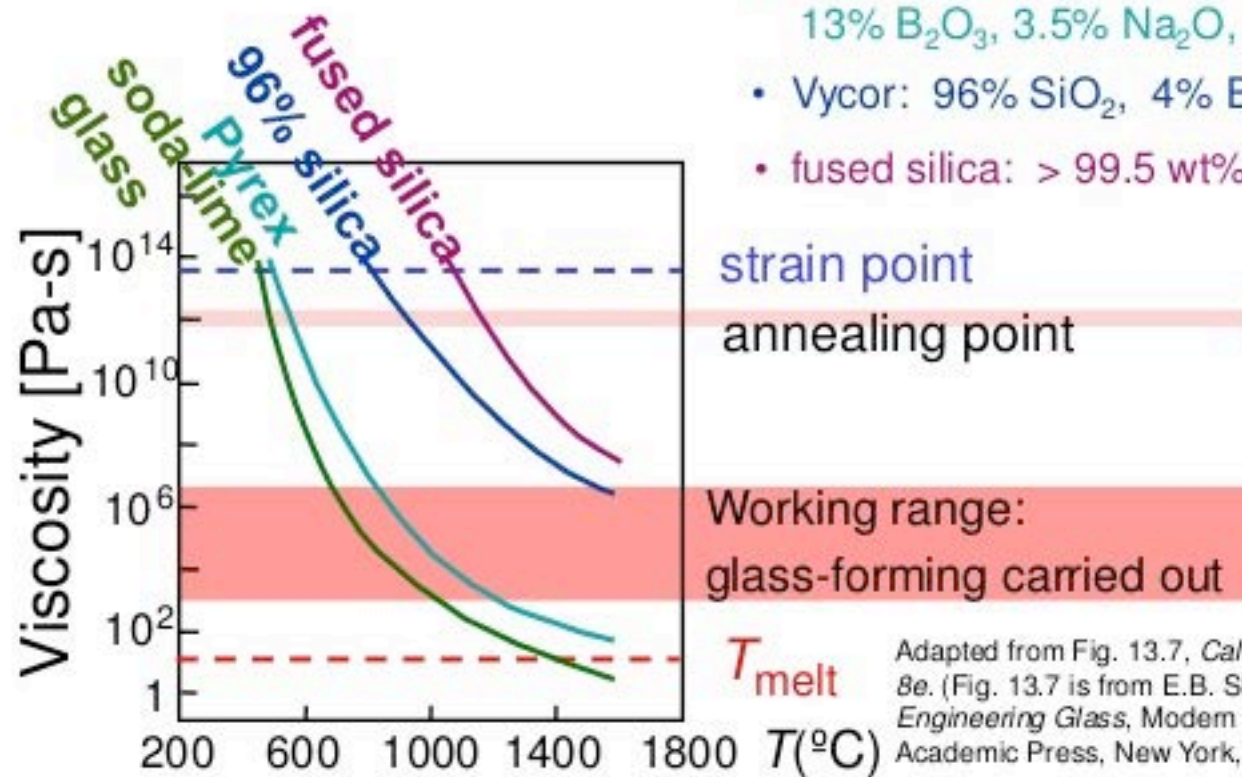
Sc
La
Na
K
Rb
Cs

Intermediate

Ti
Zr
Pb
Al
Th

Log Glass Viscosity vs. Temperature

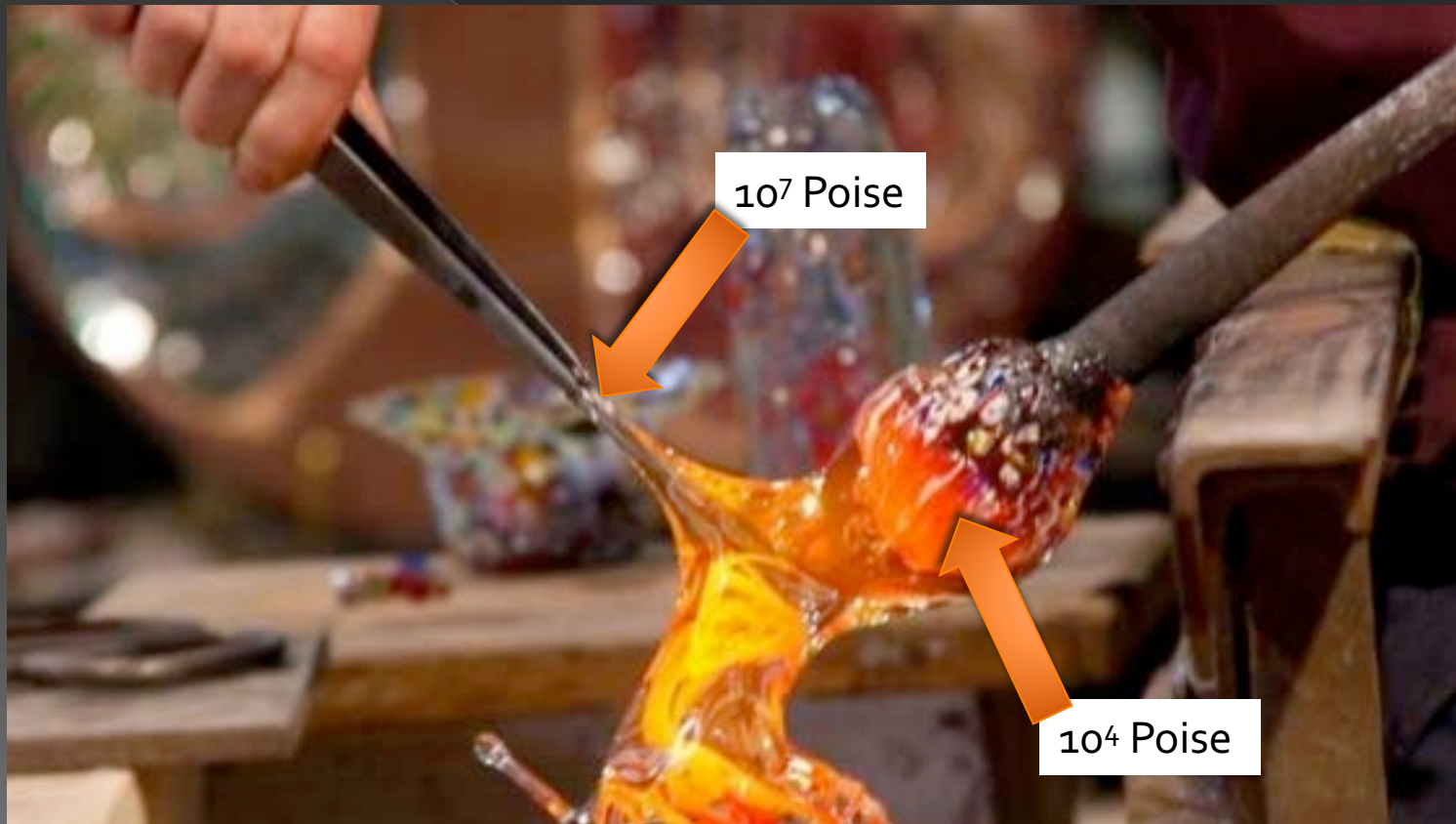
- Viscosity decreases with T
- soda-lime glass: 70% SiO_2
balance Na_2O (soda) & CaO (lime)
- borosilicate (Pyrex):
13% B_2O_3 , 3.5% Na_2O , 2.5% Al_2O_3
- Vycor: 96% SiO_2 , 4% B_2O_3
- fused silica: > 99.5 wt% SiO_2



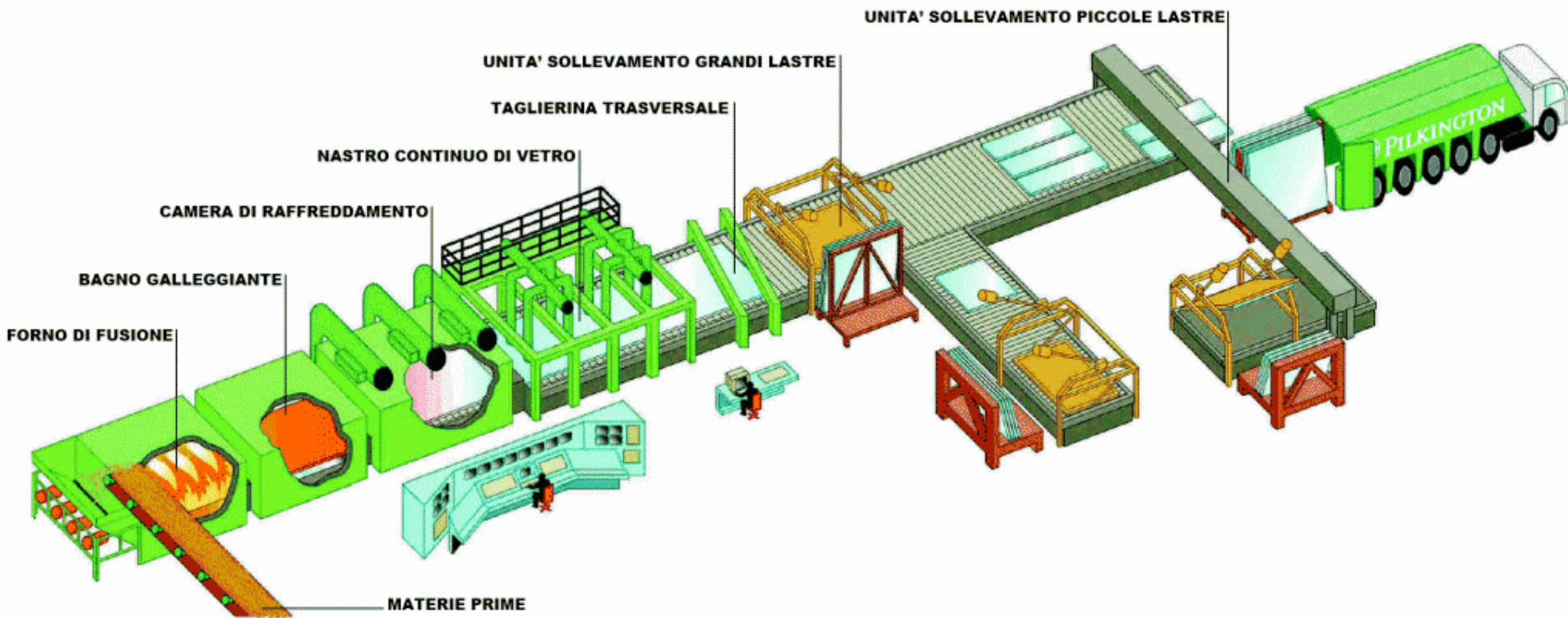
Adapted from Fig. 13.7, Callister & Rethwisch 8e. (Fig. 13.7 is from E.B. Shand, *Engineering Glass*, Modern Materials, Vol. 6, Academic Press, New York, 1968, p. 262.)



Glass Viscosity and Workability



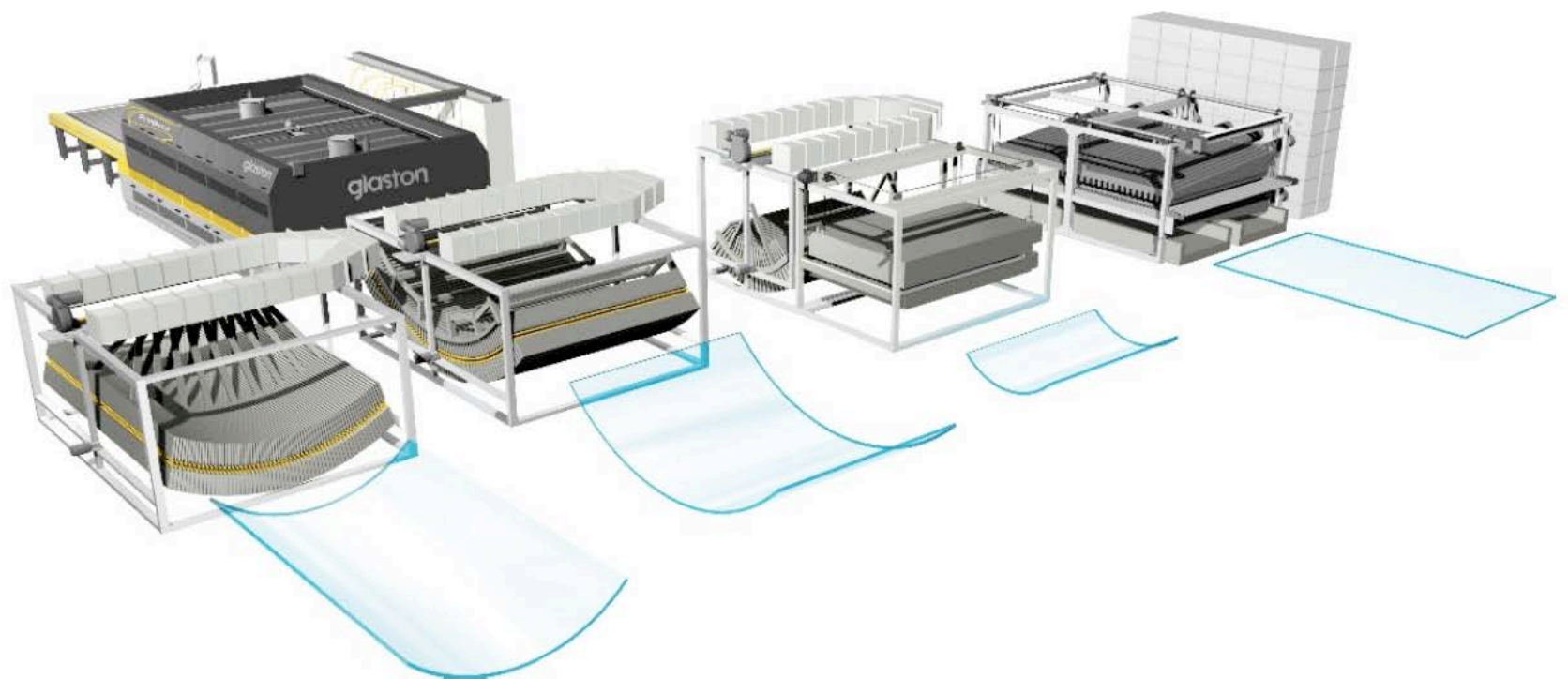
Pilkington process

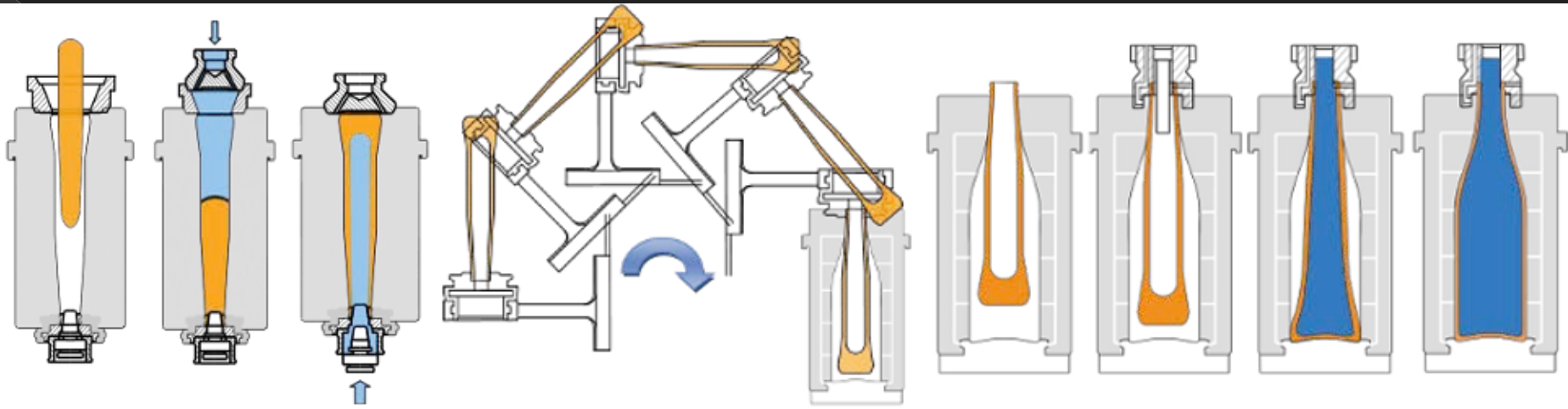


<https://www.youtube.com/watch?v=ig4G5WbOMLc>



Glass bending





Bottle production line

http://www.youtube.com/watch?v=A_M8WBJMcMo

Dielectrics

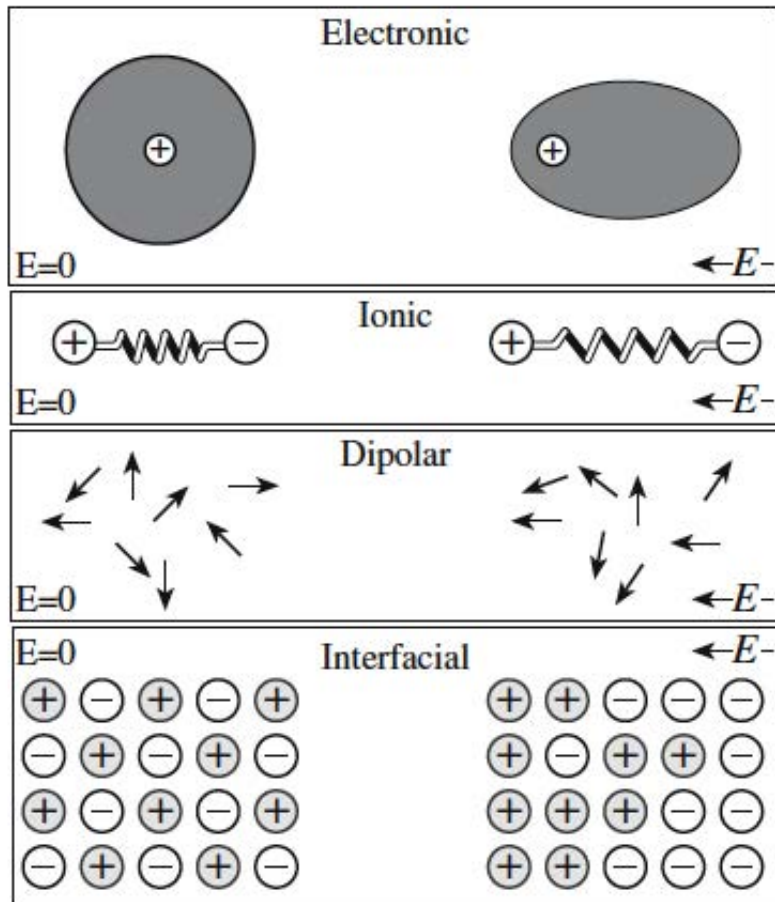


FIGURE 31.1 Illustration of the different polarization mechanisms in a solid.

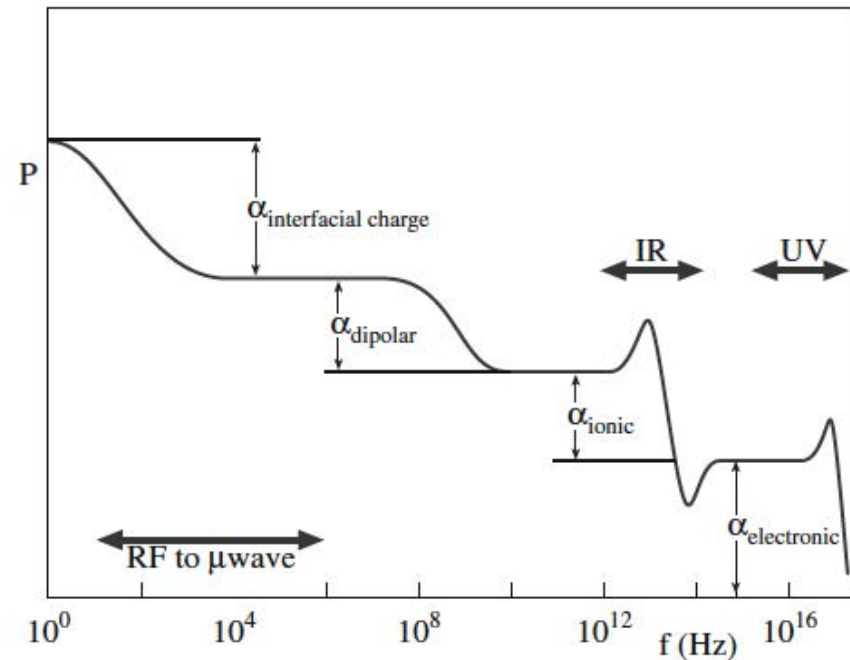


FIGURE 31.2 Frequency dependence of polarization.

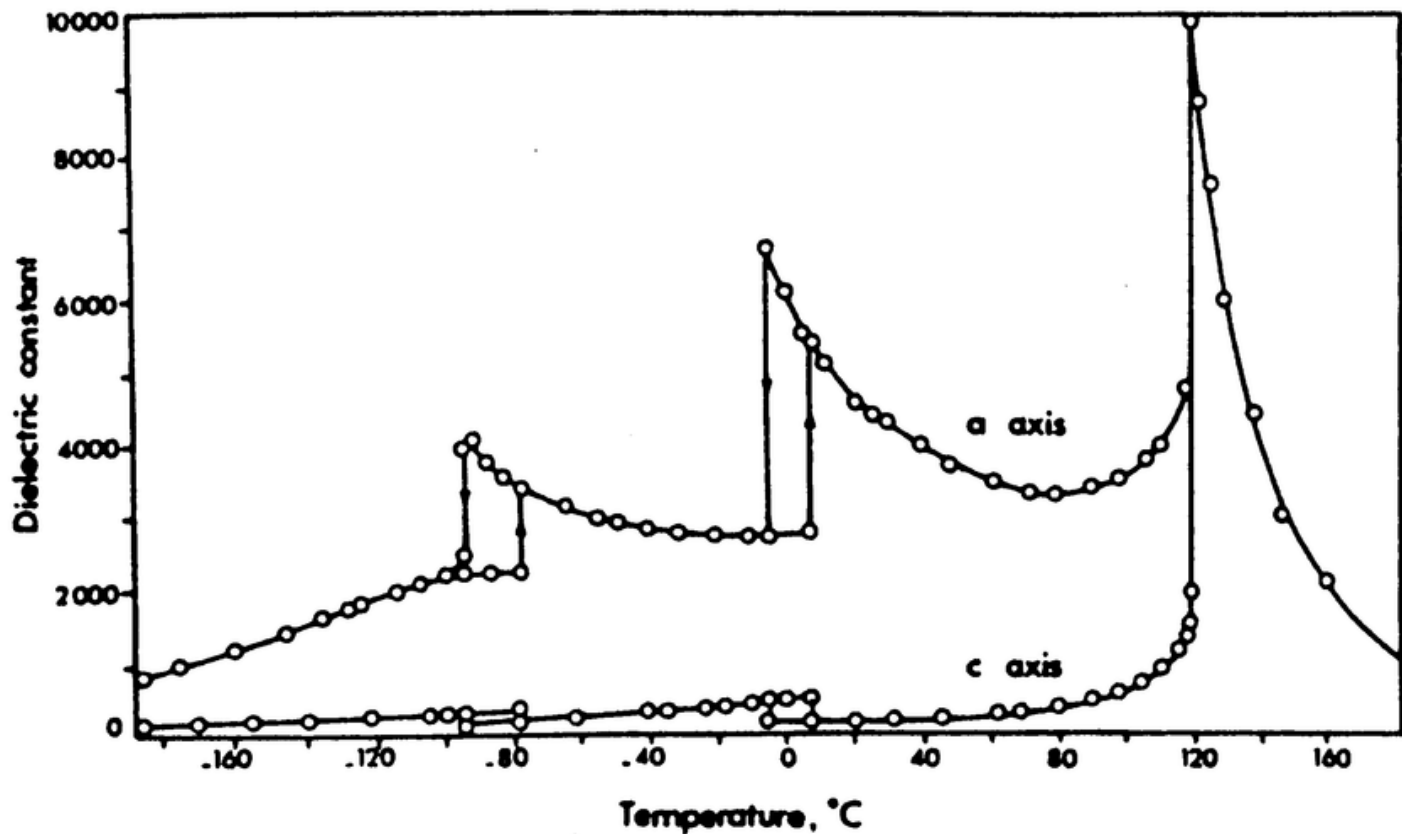
TABLE 31.2 Dielectric Constants of Various Ceramics

<i>Material</i>	<i>κ at 1 MHz</i>	<i>Material</i>	<i>κ at 1 MHz</i>
Diamond	5.5–6.6	Al ₂ O ₃	8.8
SiO ₂	3.7–3.8	MgO	9.6
NaCl	5.9	BaTiO ₃	3000
Mica	5.4–8.7	Pyrex glass	4.0–6.0
Soda-lime glass	7.0–7.6	TiO ₂	14–110
Steatite	5.5–7.5	Forsterite	6.2
(SiO ₂ + MgO + Al ₂ O ₃)		(2MgO · SiO ₂)	
Cordierite	4.5–5.4	Mullite	6.6
(SiO ₂ +MgO + Al ₂ O ₃)			
High-lead glass	19		

TABLE 31.4 Dielectric Strengths for Various Ceramics

<i>Material</i>	<i>Dielectric strength (MV/cm at 25°C)</i>
Al ₂ O ₃ (99.5%)	0.18
Al ₂ O ₃ (94.0%)	0.26
High-voltage porcelain	0.15
Steatite porcelain	0.10
Lead glass	0.25
Lime glass	2.5
Borosilicate glass	5.8
Fused quartz	6.6
Quartz crystal	6.0
NaCl [100], [111], [110]	2.5, 2.2, 2.0
Muscovite mica	10.1

Dielectric constant of BaTiO_3



Positive Temperature coefficient, PTC of Barium Titanate

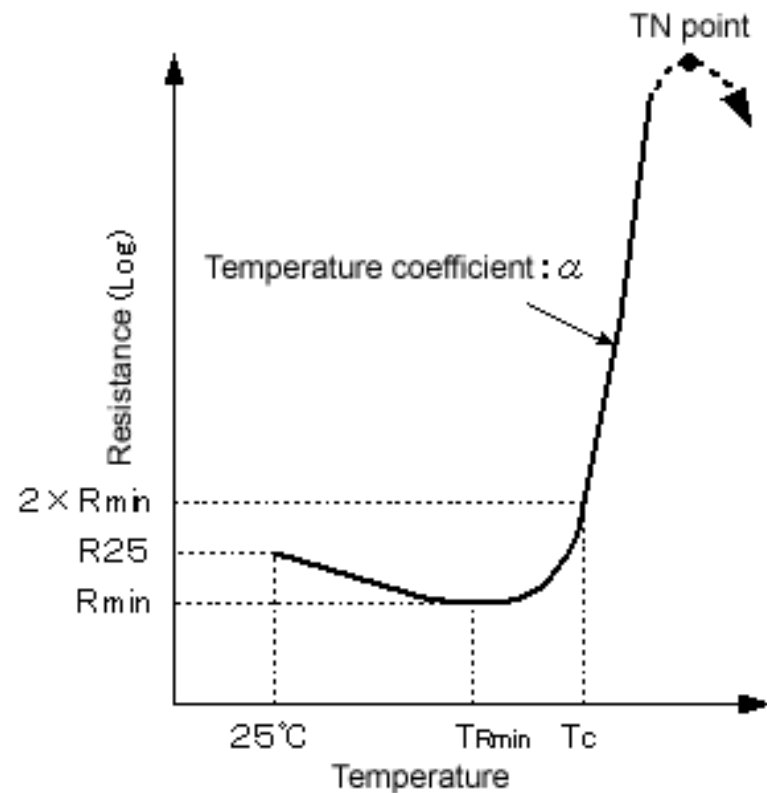
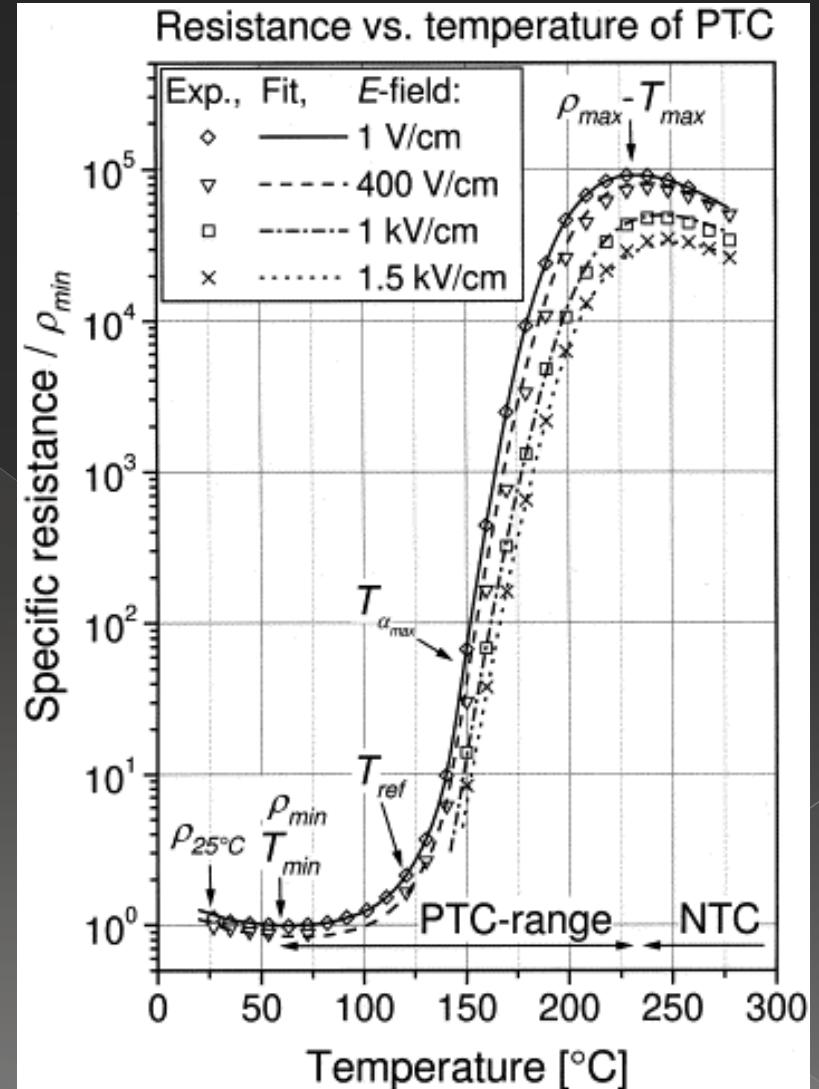
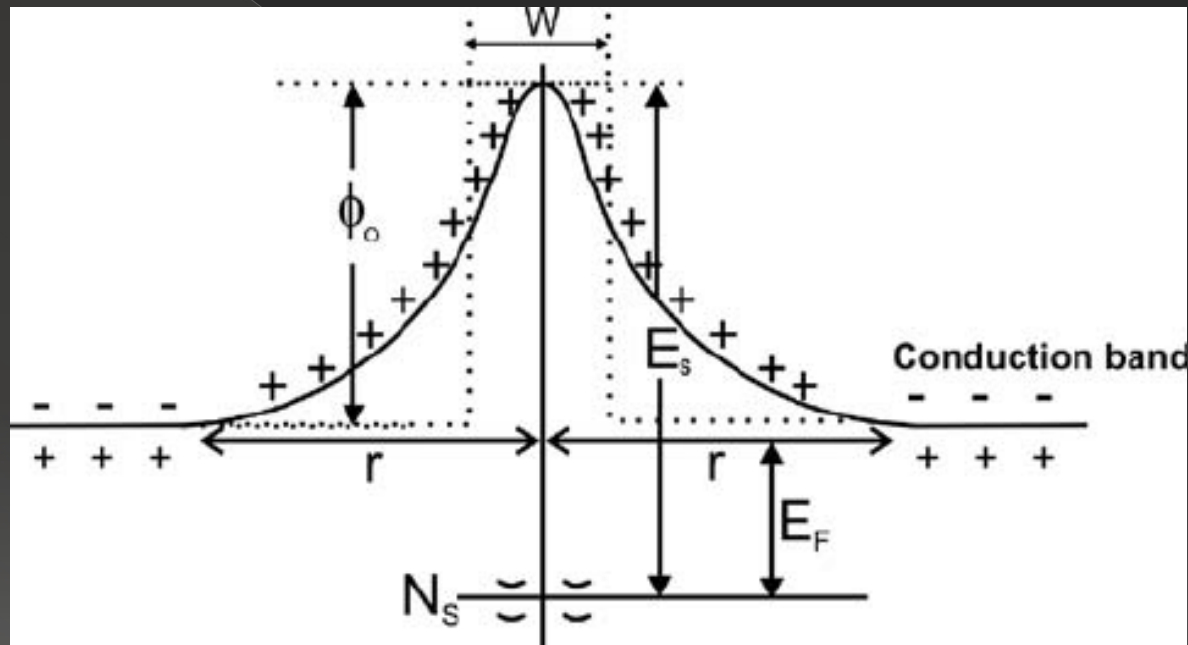


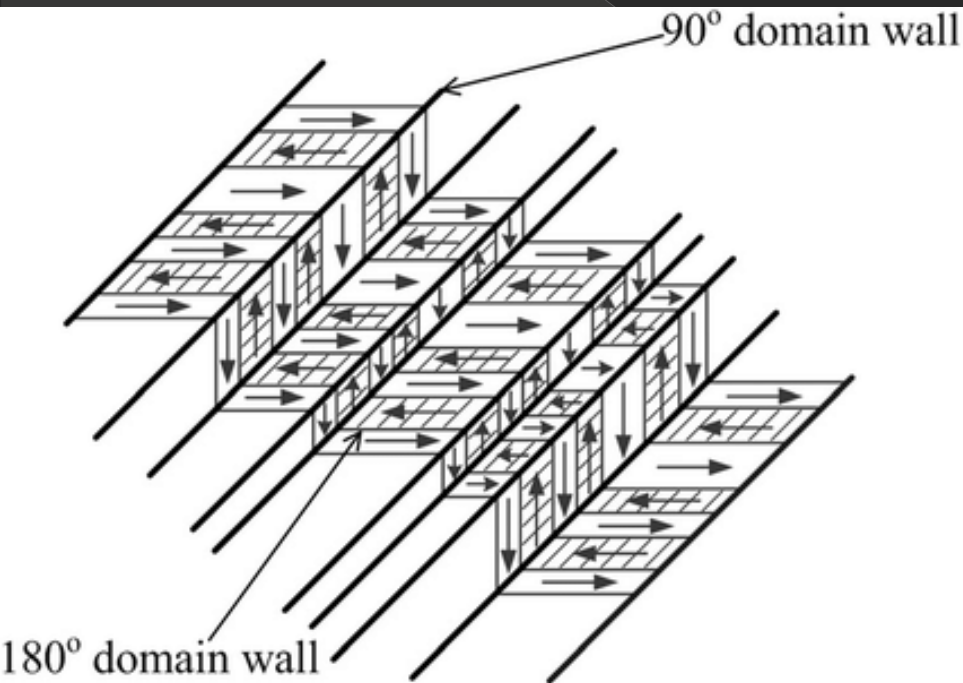
Fig. 2 Definition of resistance-temperature characteristics and Curie temperature



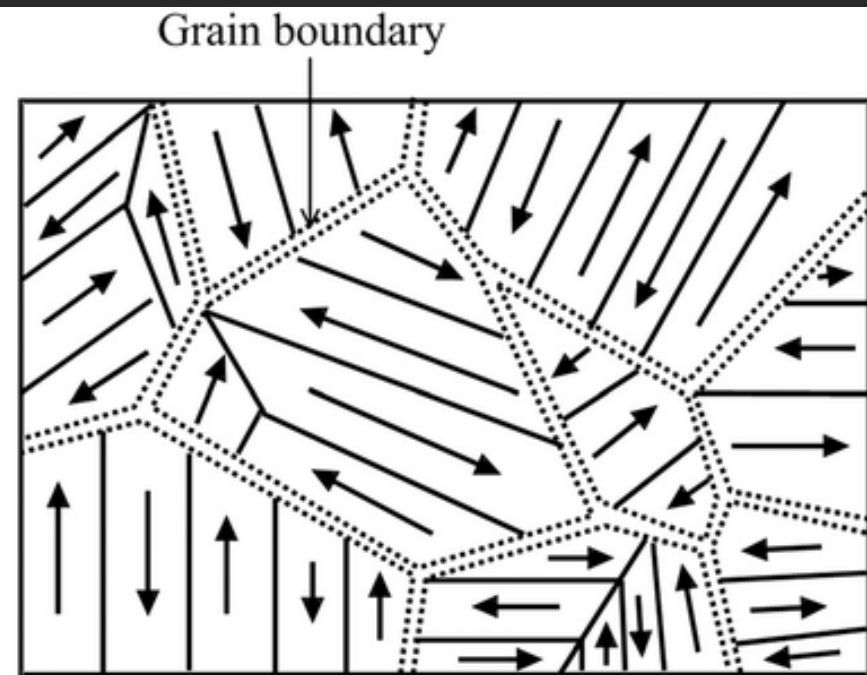
Explanation for PTC behavior of BaTiO_3



Domains in ferroelectric depend on the orientation of the polarization

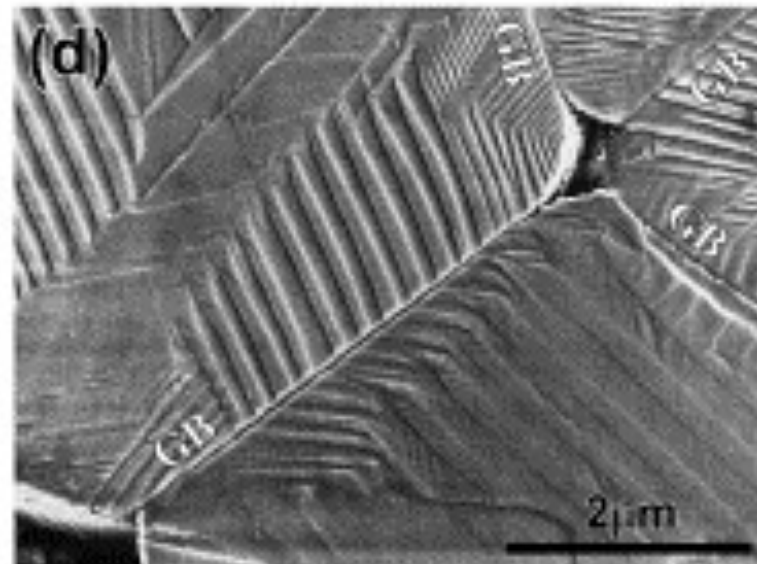
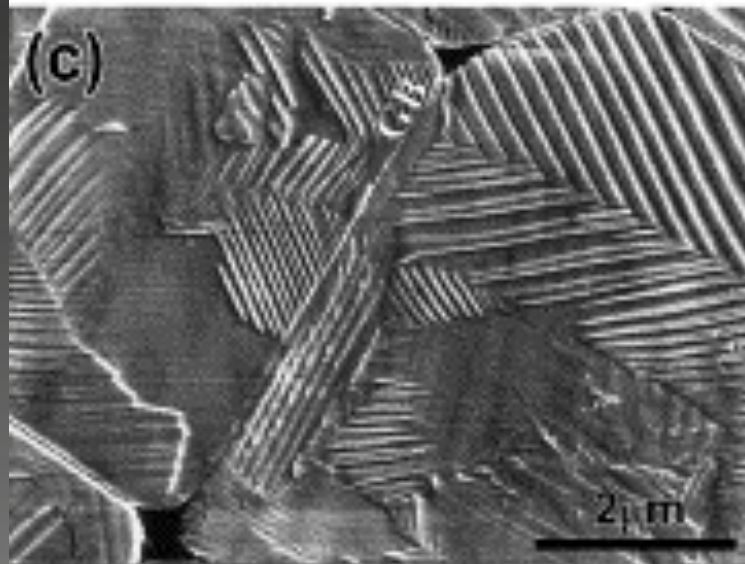
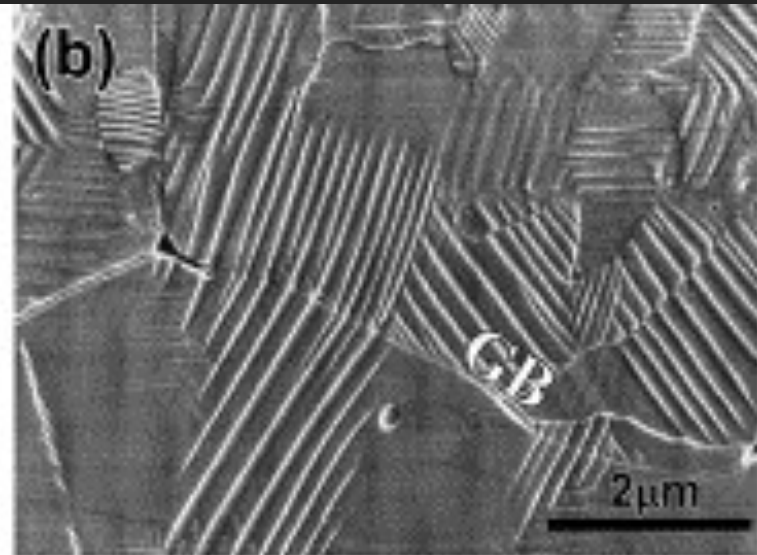
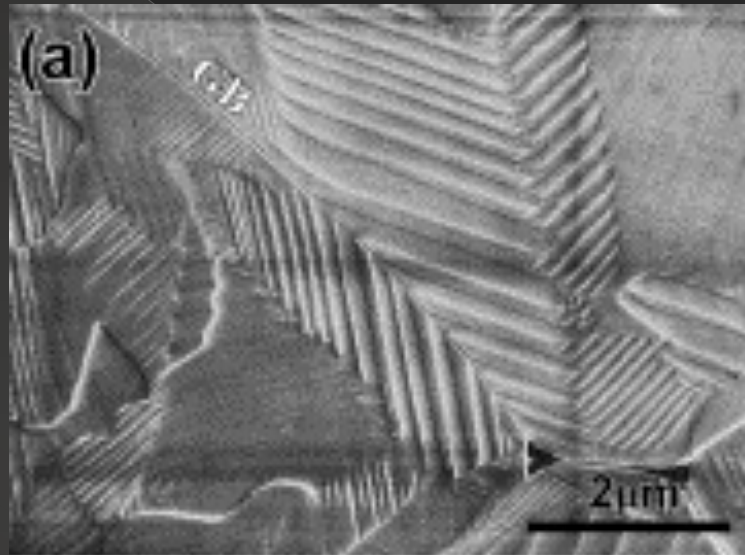


(a)



(b)

Ferroelectric domain in a ferroelectric materials



Non destructive testing Techniques

- ⦿ Visual inspection
- ⦿ Penetrant dyes <https://www.youtube.com/watch?v=xEK-c1pkTUI>
- ⦿ Ultrasonic testing <https://www.youtube.com/watch?v=UM6XKvXWVFA>
- ⦿ Radiographic testing <https://www.youtube.com/watch?v=IcWjZbXiFkM>
- ⦿ Magnetoscopic testing
- ⦿ Eddy currents

Proof testing:

- 1) load configuration as similar as possible to service condition
- 2) one single test slightly above load/stress values in service



Liquid penetrant dyes



1 Crack filled with dirt



2 Ideally cleaned



3 Application of penetrant



4 Intermediate cleaning



5 Application of developer



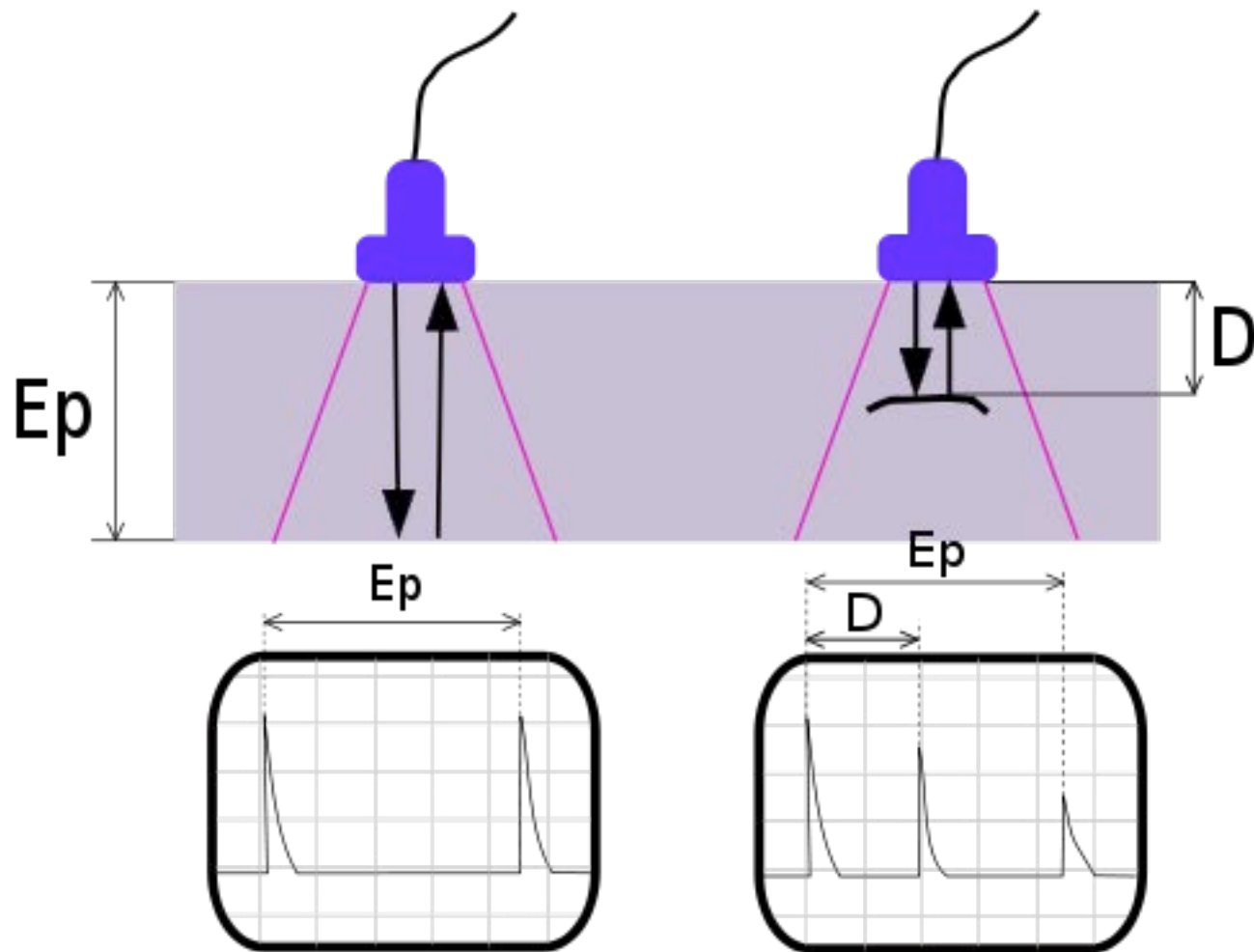
6 Crack indication





Fluorescent penetrant dye revealed with a Wood lamp

Ultrasonic testing





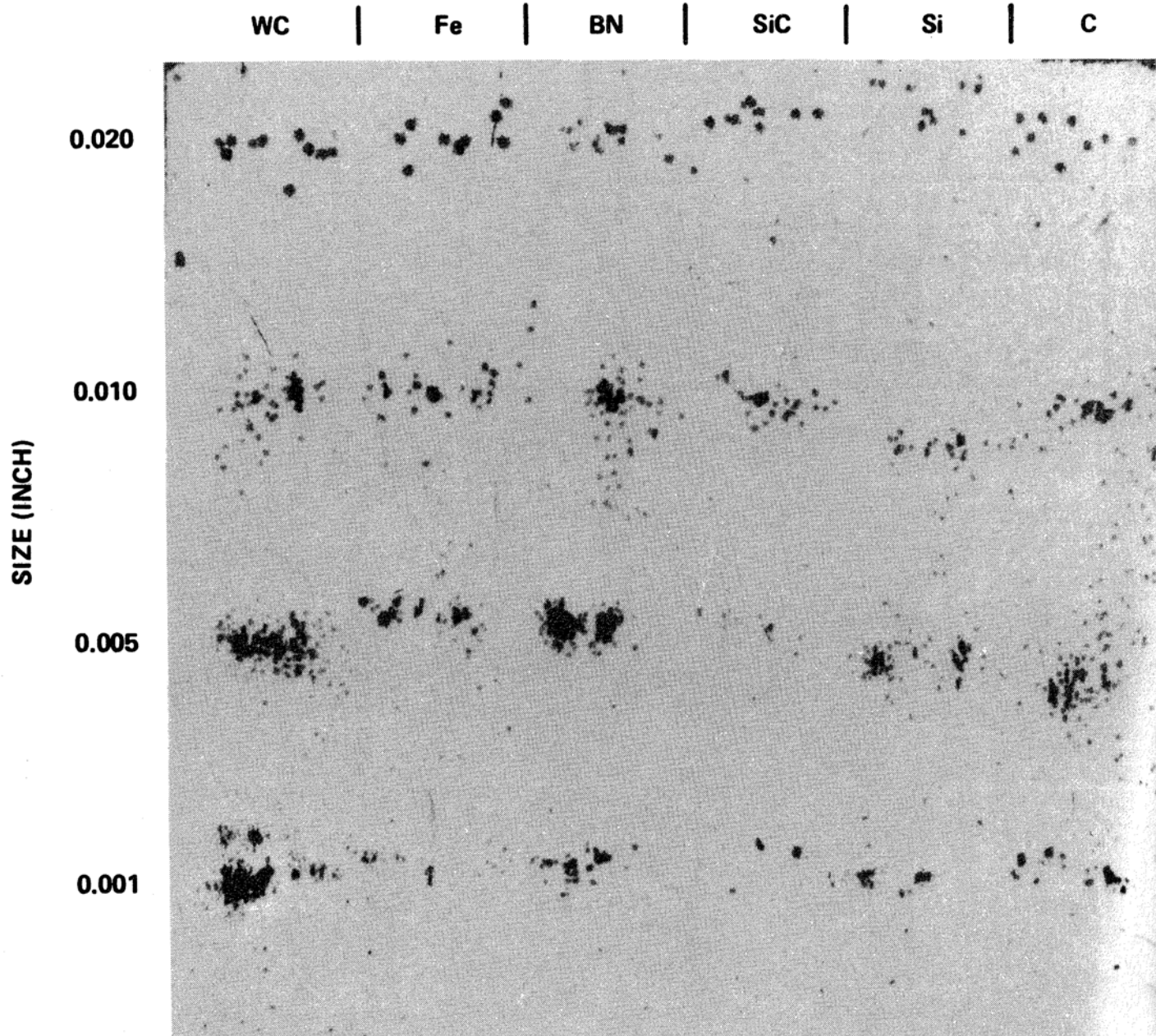
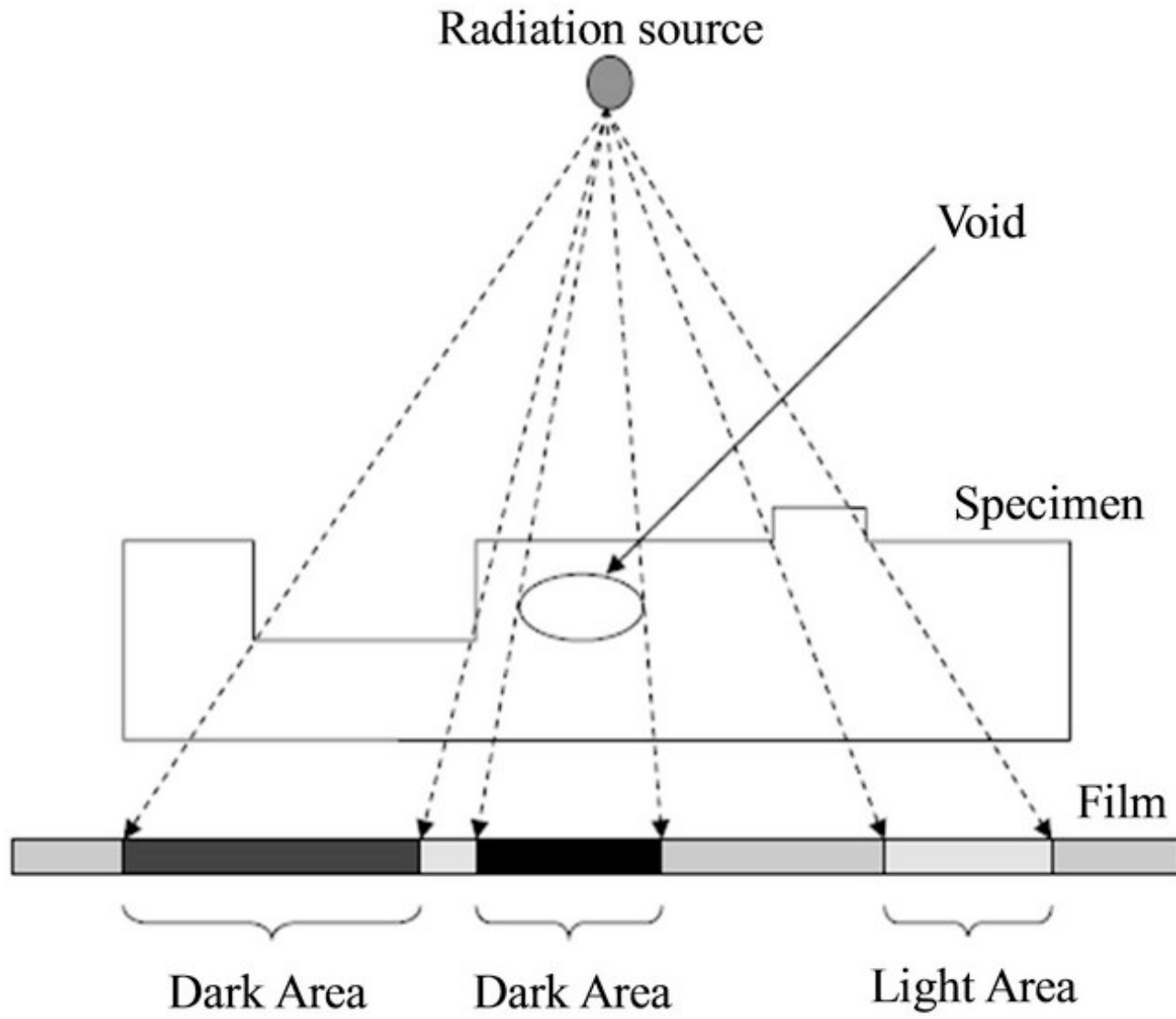
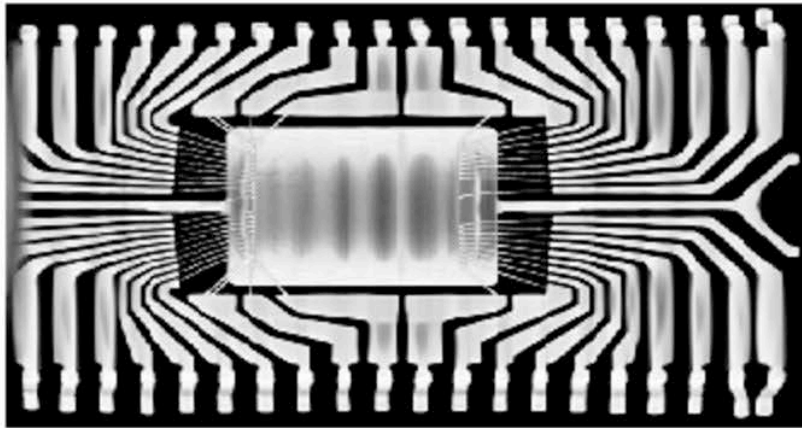
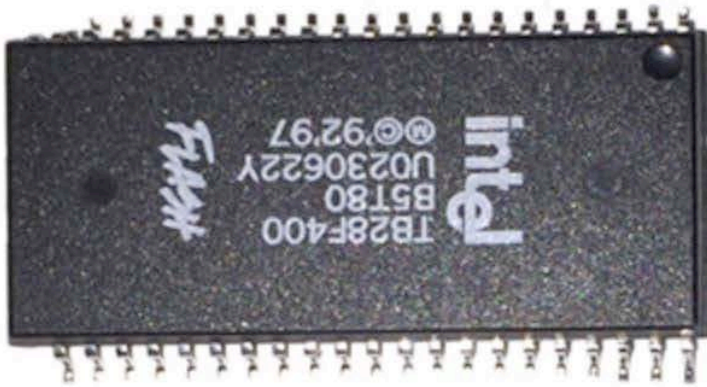


Figure 13.10 Ultrasonic C-scan with a 25-MHz transducer of a 0.64-cm (0.25-in.)-thick hot-pressed Si_3N_4 plate. (Courtesy Garrett Turbine Engine Company, Phoenix, Ariz., Division of Allied-Signal Aerospace.)

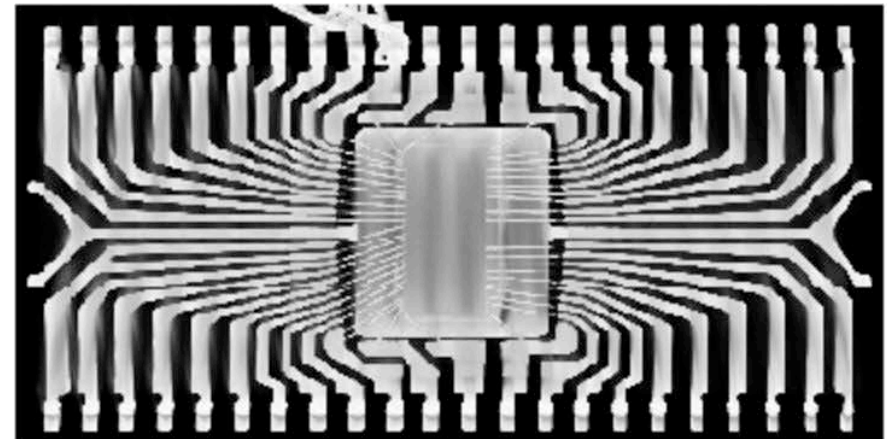
Radiographic testing



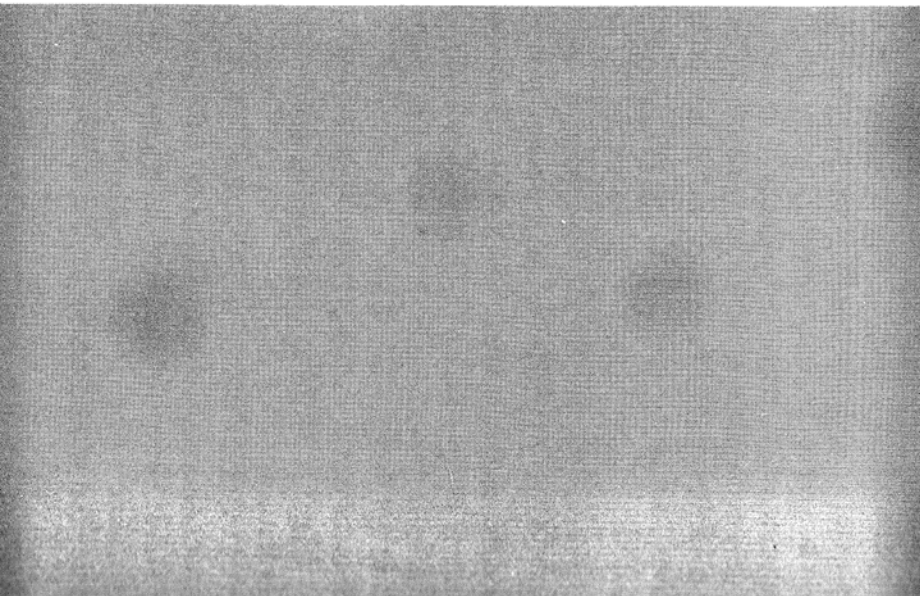
Radiographic testing of two chips



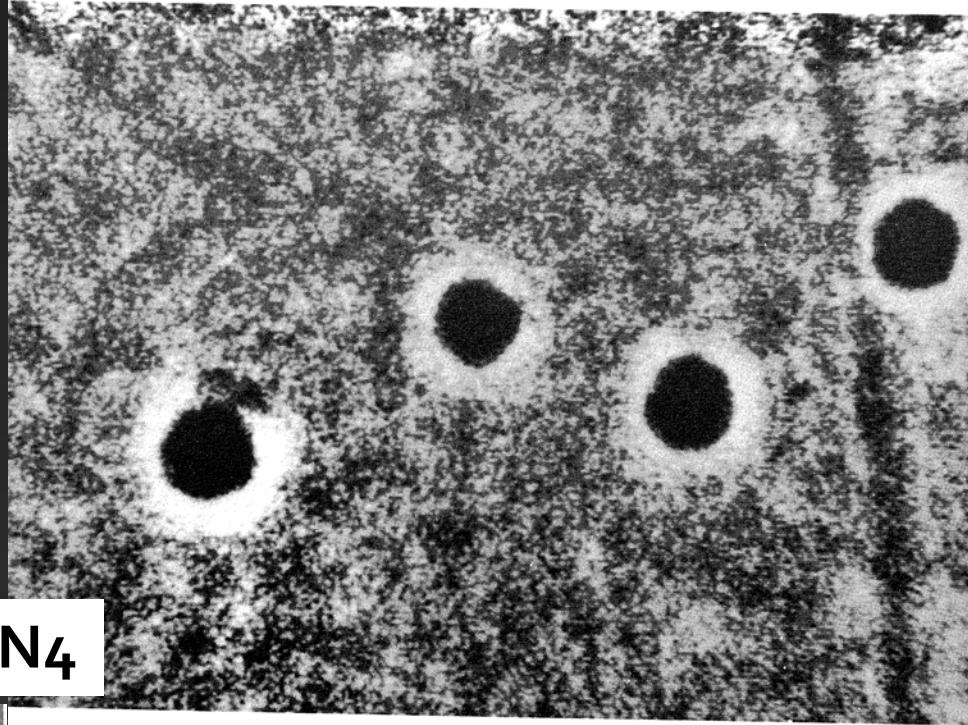
Counterfeit



Authentic



X ray image of C inclusions in Si₃N₄



X ray image of WC inclusions in Si₃N₄

Magnetoscopic testing

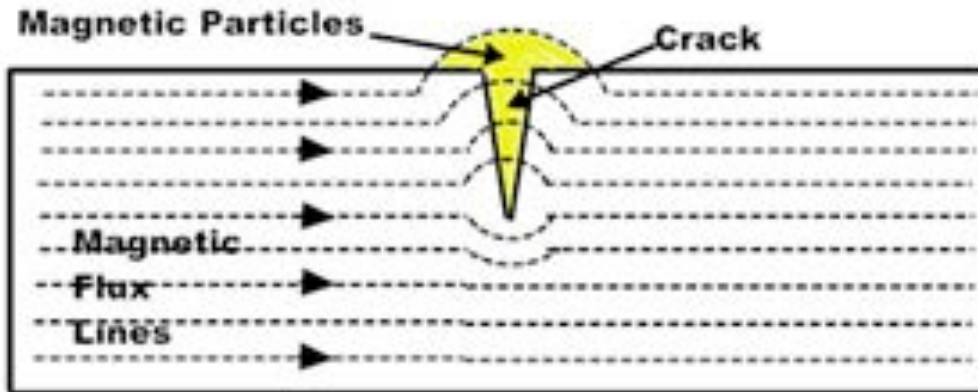


Figure 1

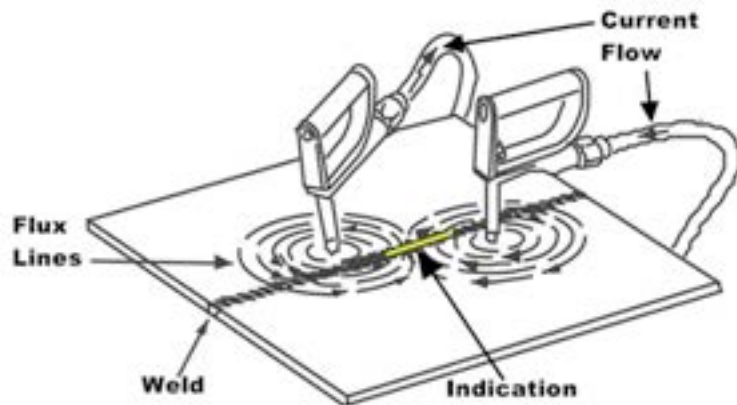
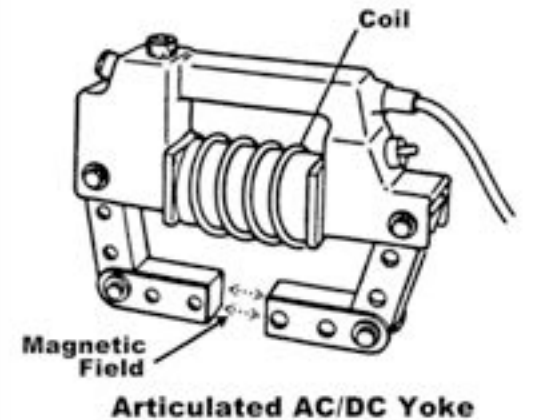
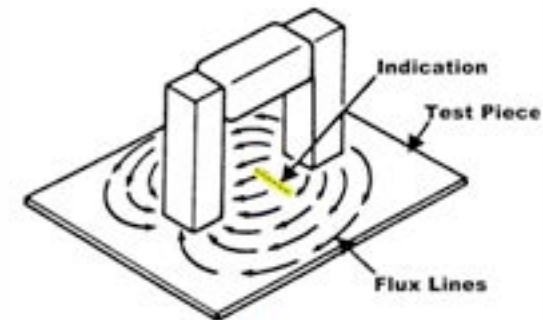


Figure 3



(a)



(b)

Figure 2

Eddy current testing

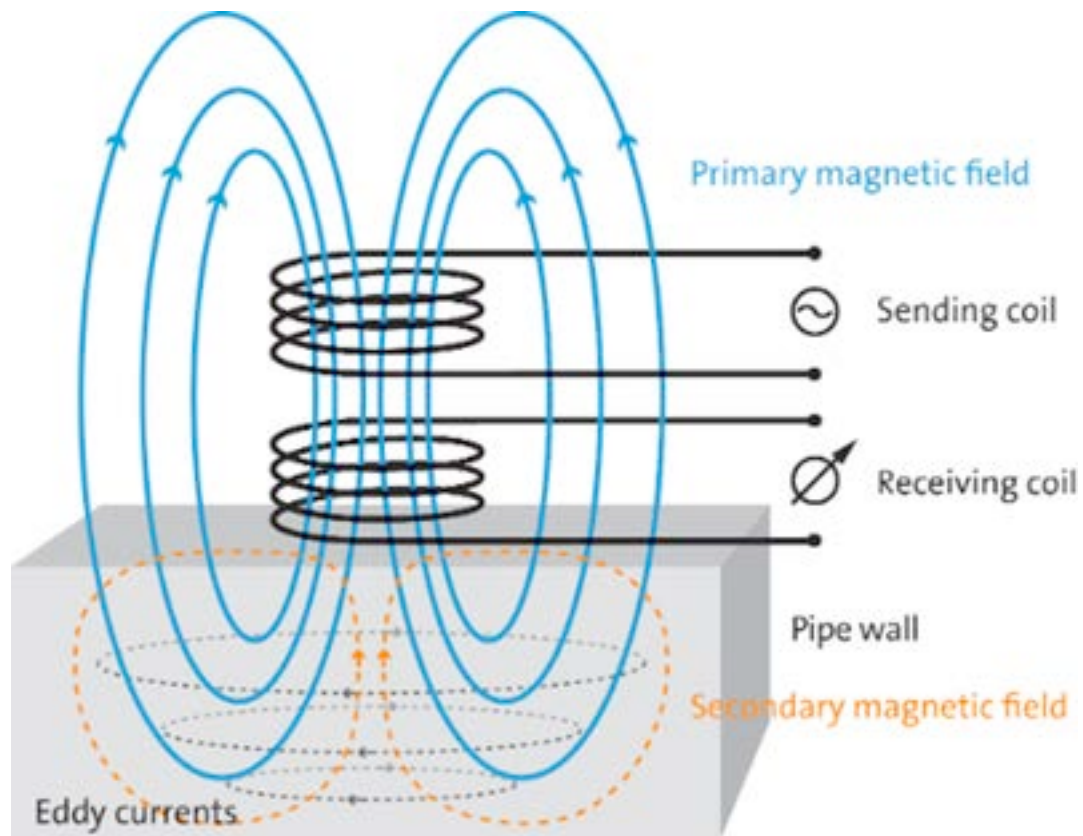


Table 14.2 Examples of Design Requirements of Various Applications and Ceramics with Properties Which Match the Requirements

Application	Requirements of the applications	Candidate ceramics	Key properties
Seal			
Turbine stator			
Heating element		O_2	
Rotary heat exchanger			

Heat sink for IC and transistor devices			
Furnace insulation			
Miniature capacitor			
High-speed, high-load bearing			
Segments of watch band			

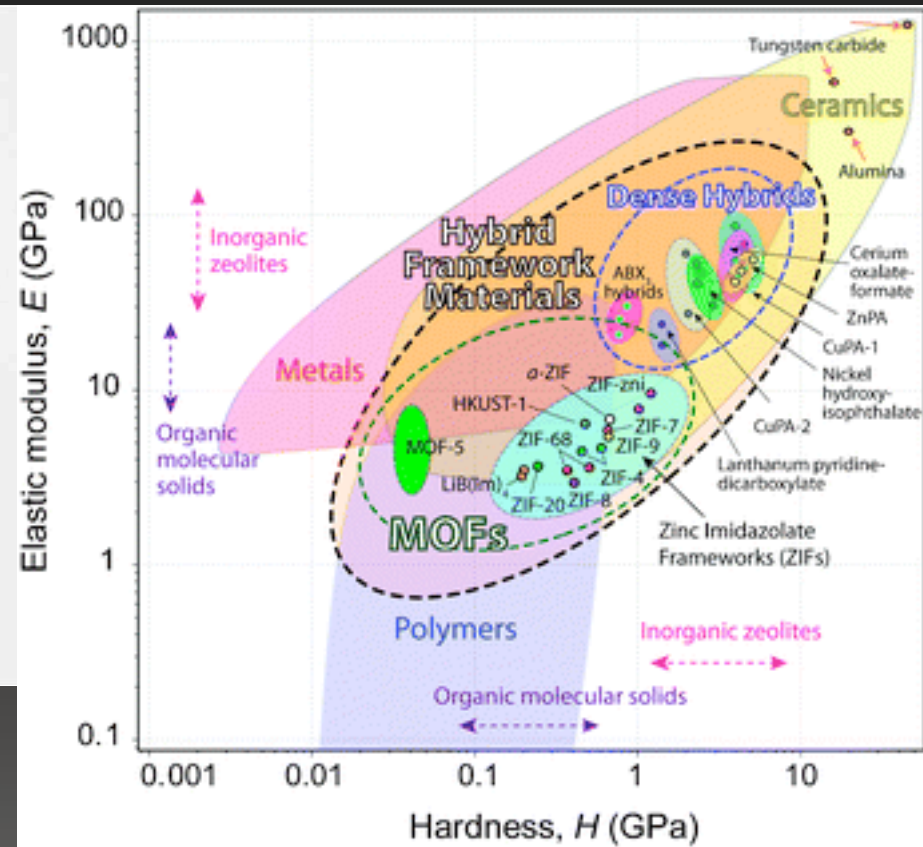
SiC Heat exchanger



Ceramic seal for taps



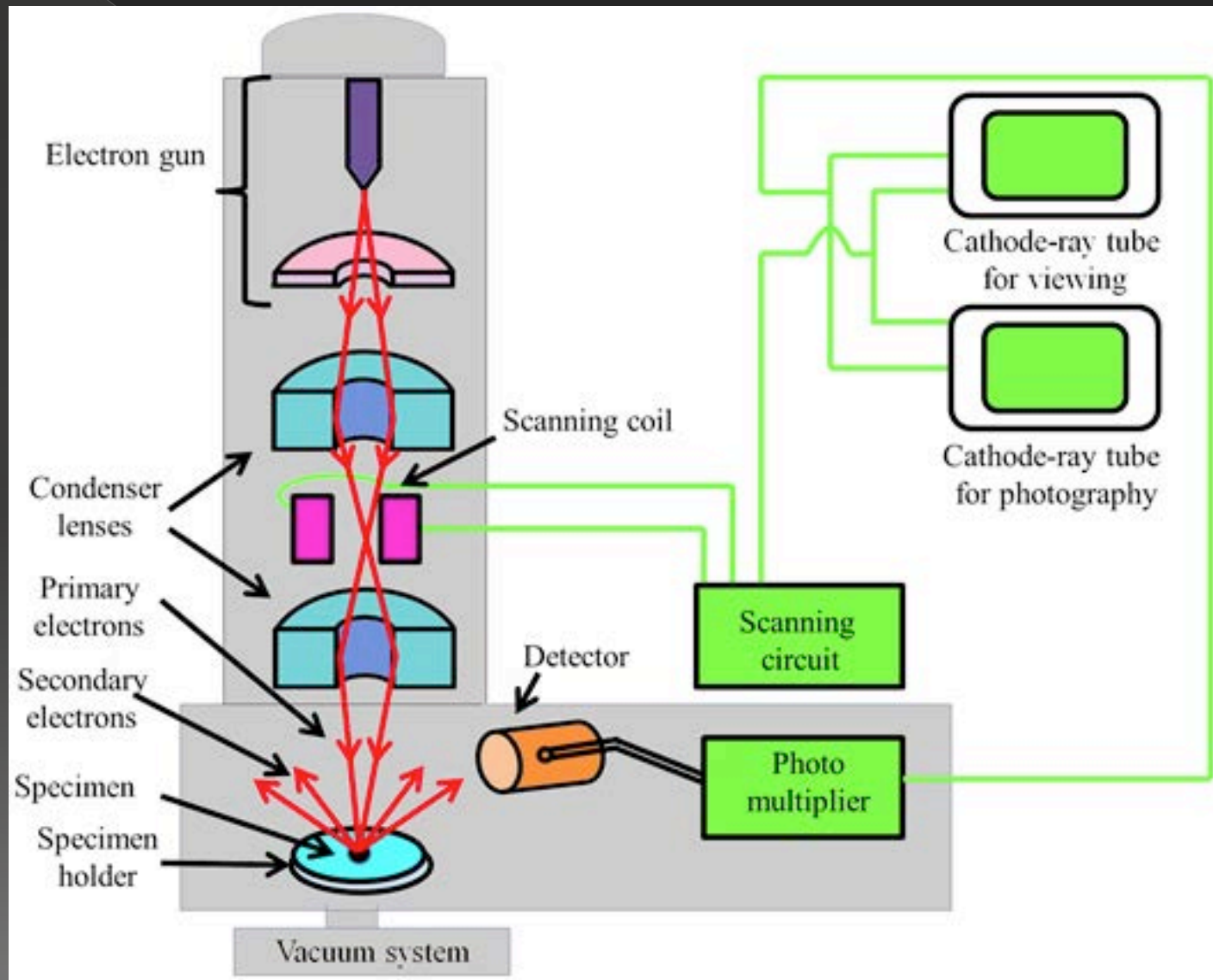
Sandblast nozzles

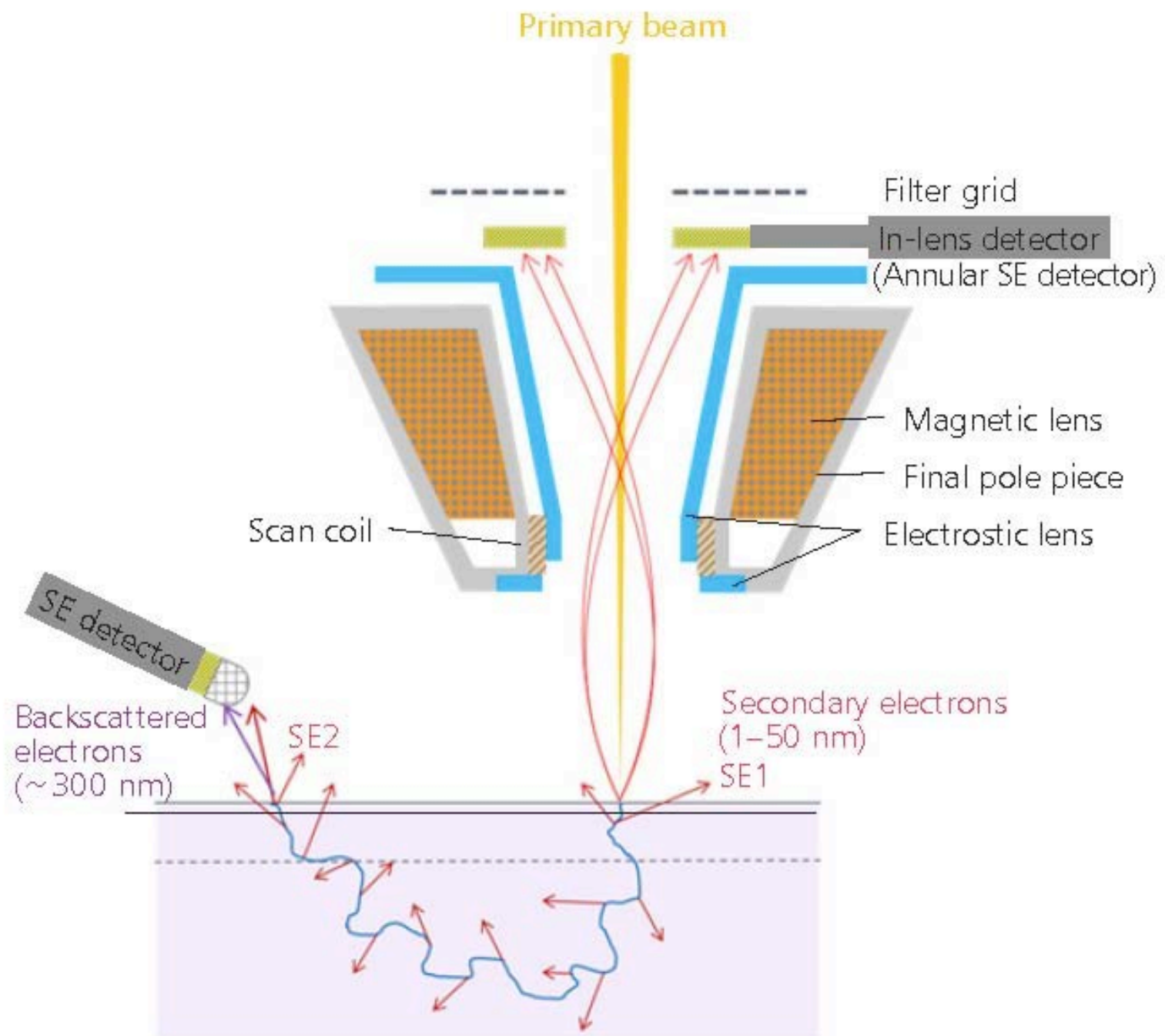


Rado watches

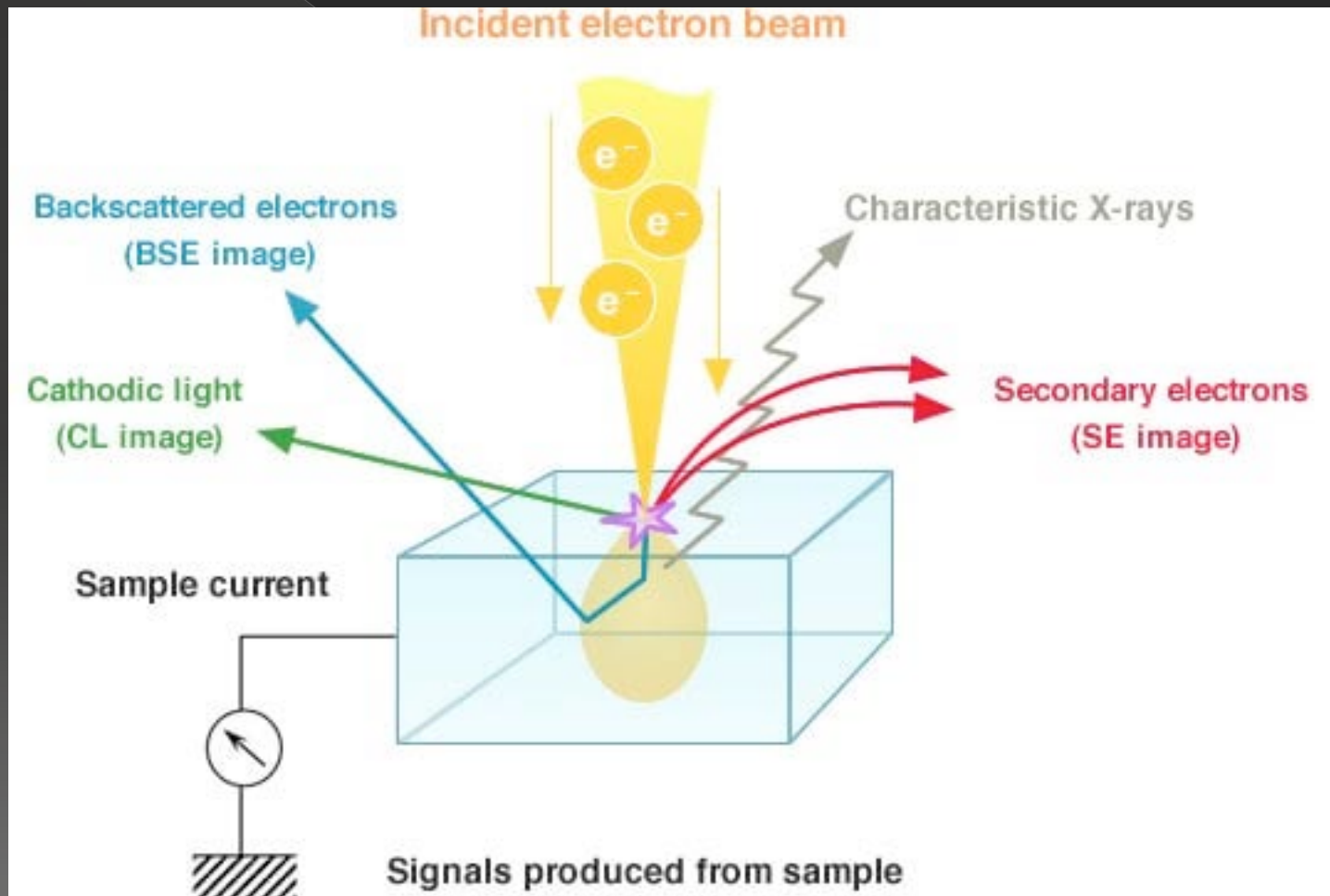


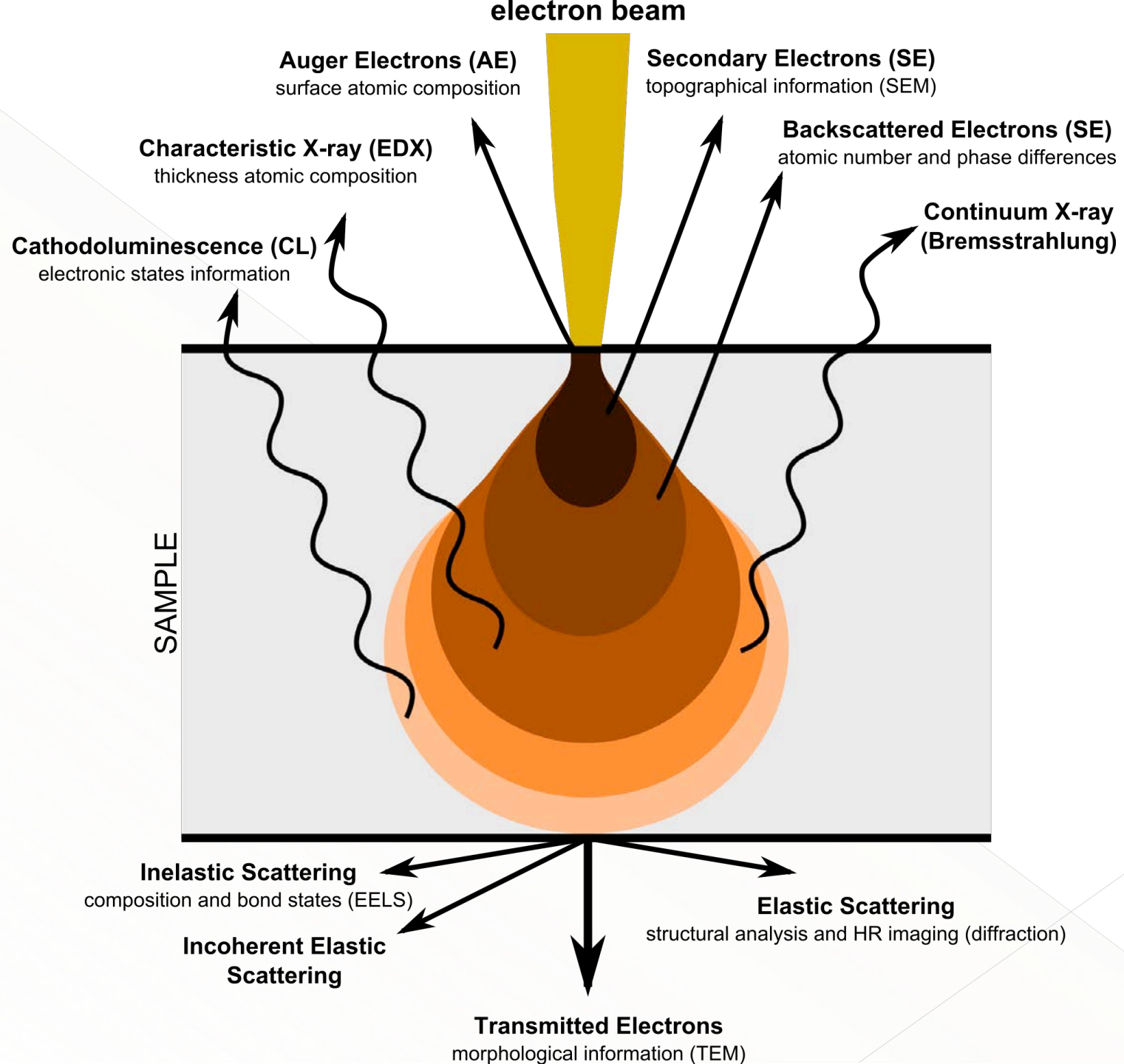
SEM fundamentals



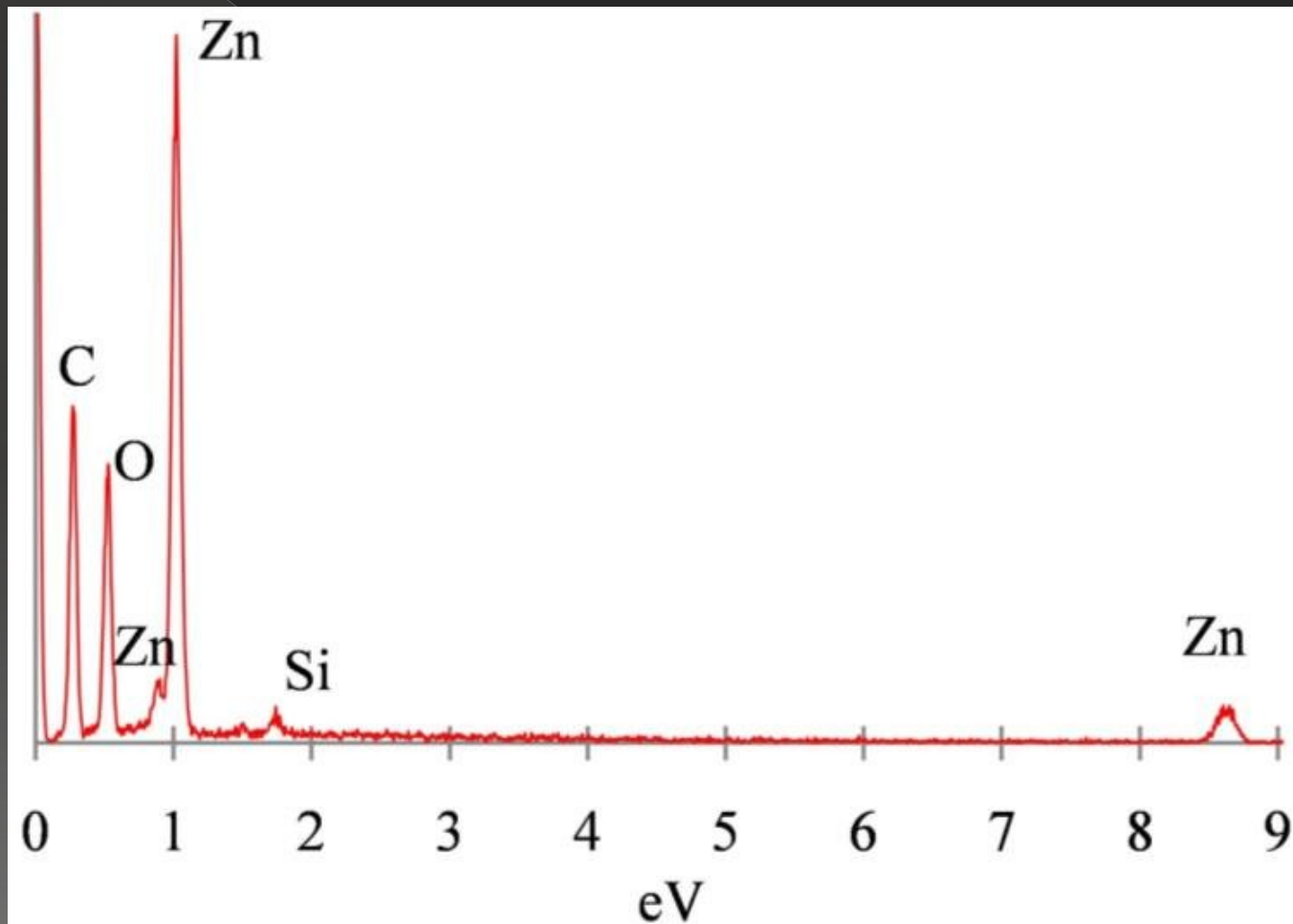


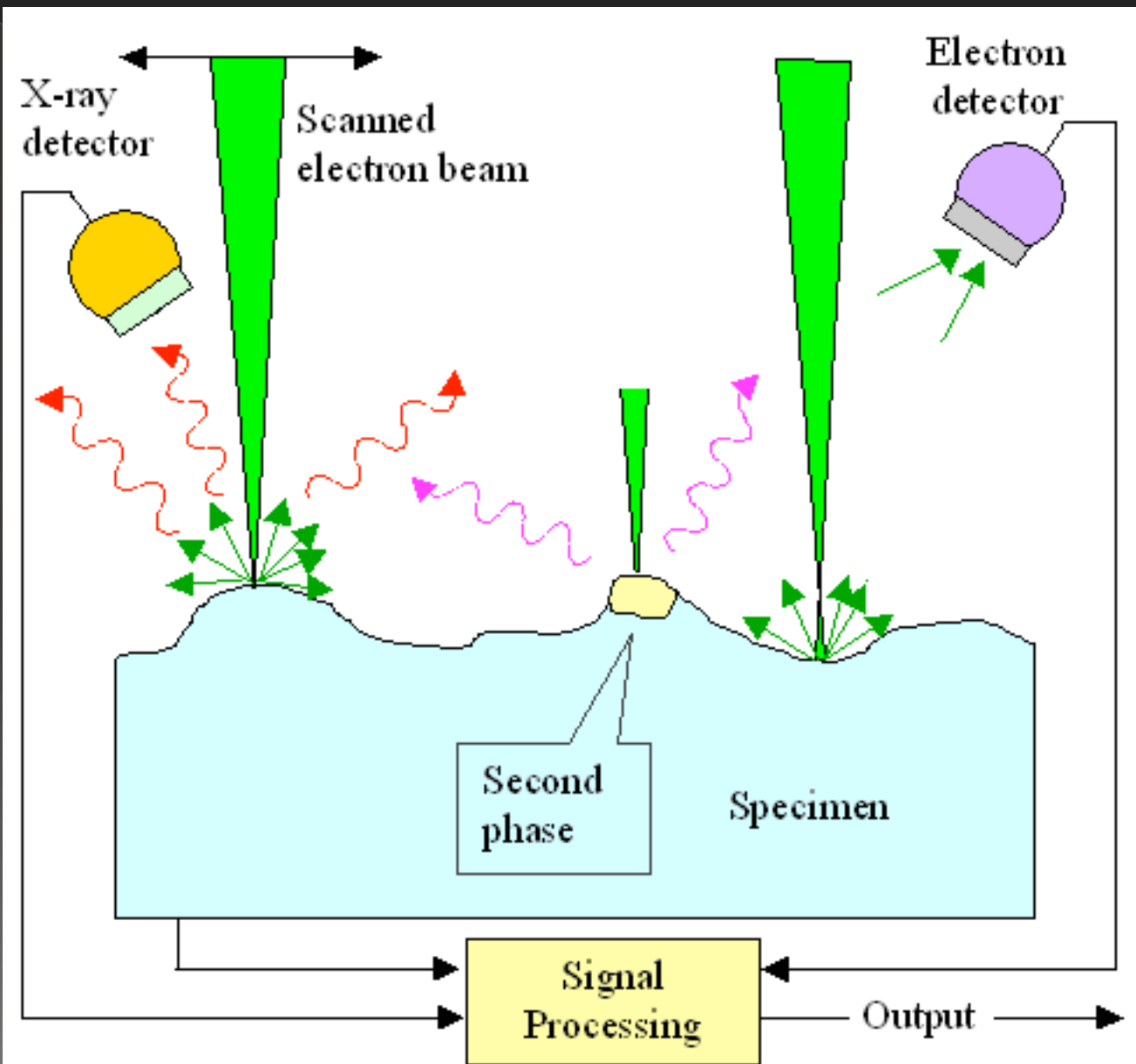
E-beam sample interaction





EDS spectrum of ZnO deposited on SiC





Compositional contrast

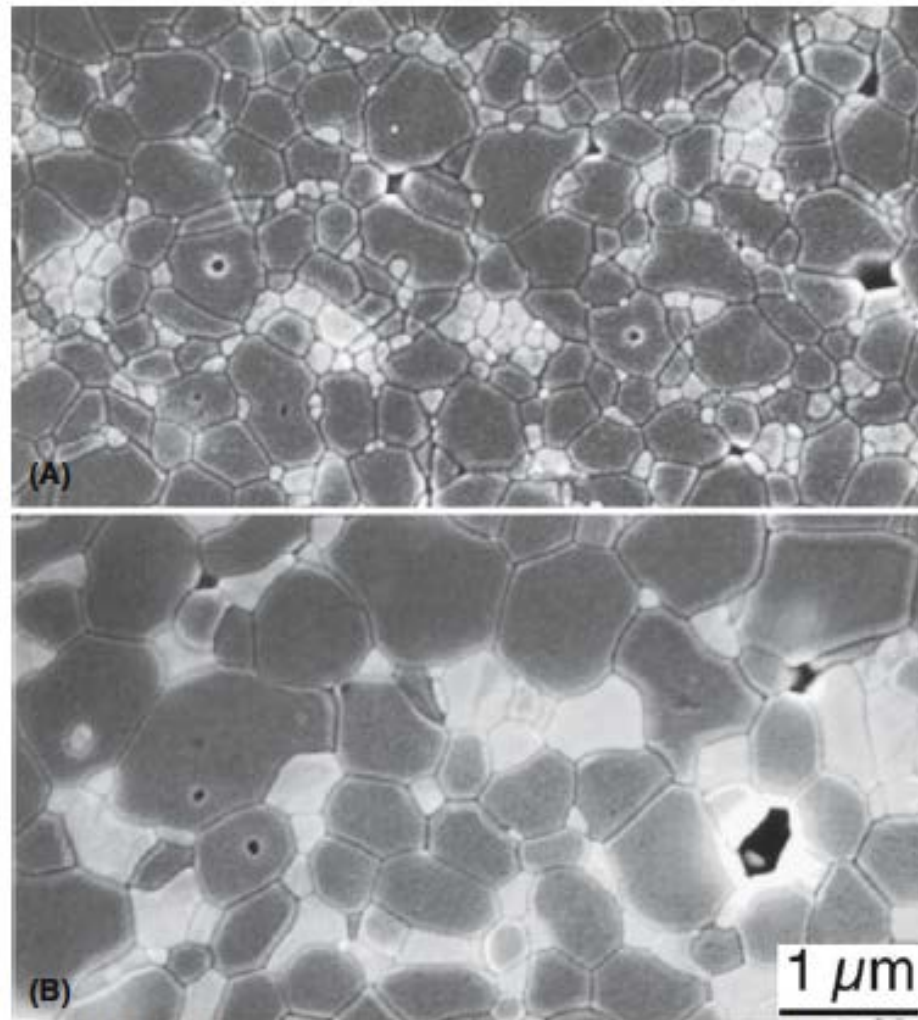
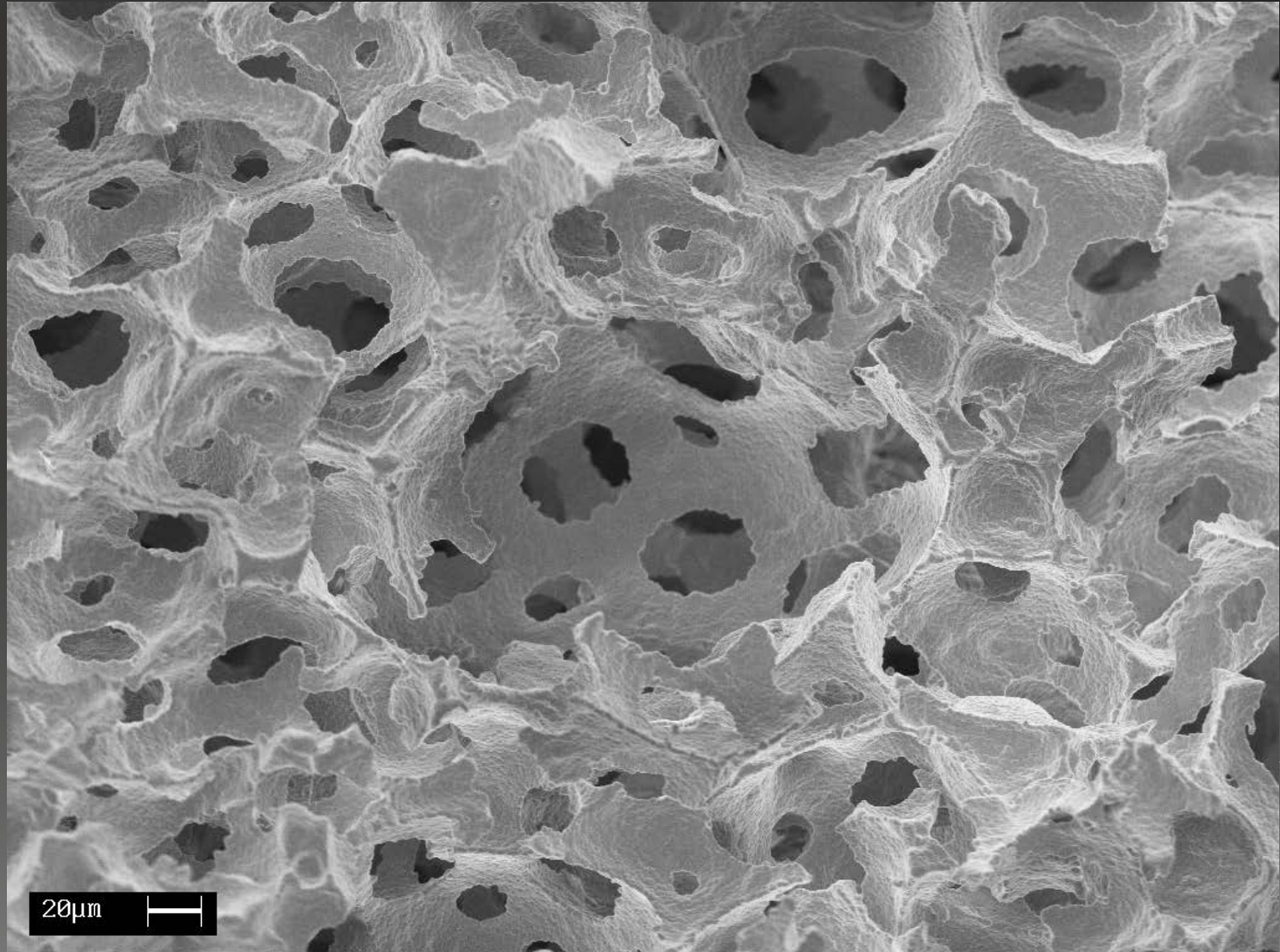
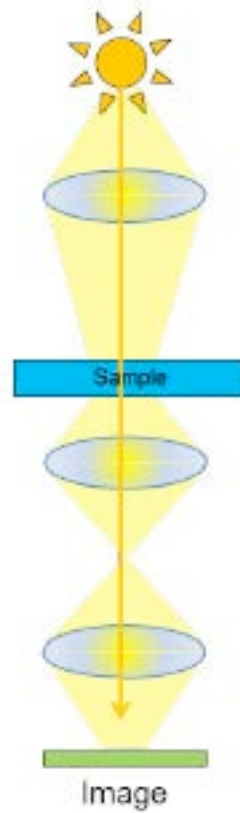


FIGURE 24.27 Two-phase ceramics. (a) As sintered and (b) heat treated at 1600°C for 30 hours. ZTA 30% (zirconia-toughened alumina with 30 vol% YSZ containing 10 molar% yttria).

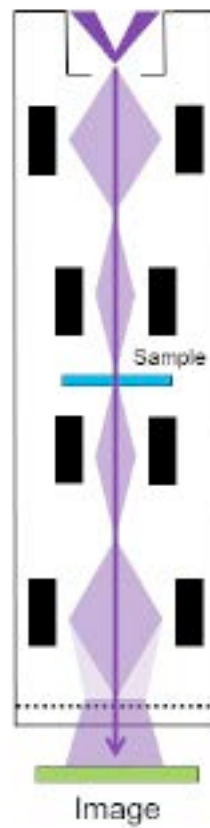
Topographical contrast



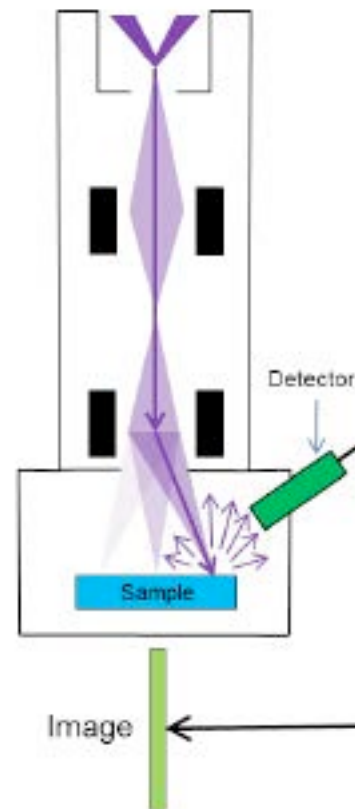
Optical
(visible light/photons)



TEM
(electrons)



SEM
(electrons)



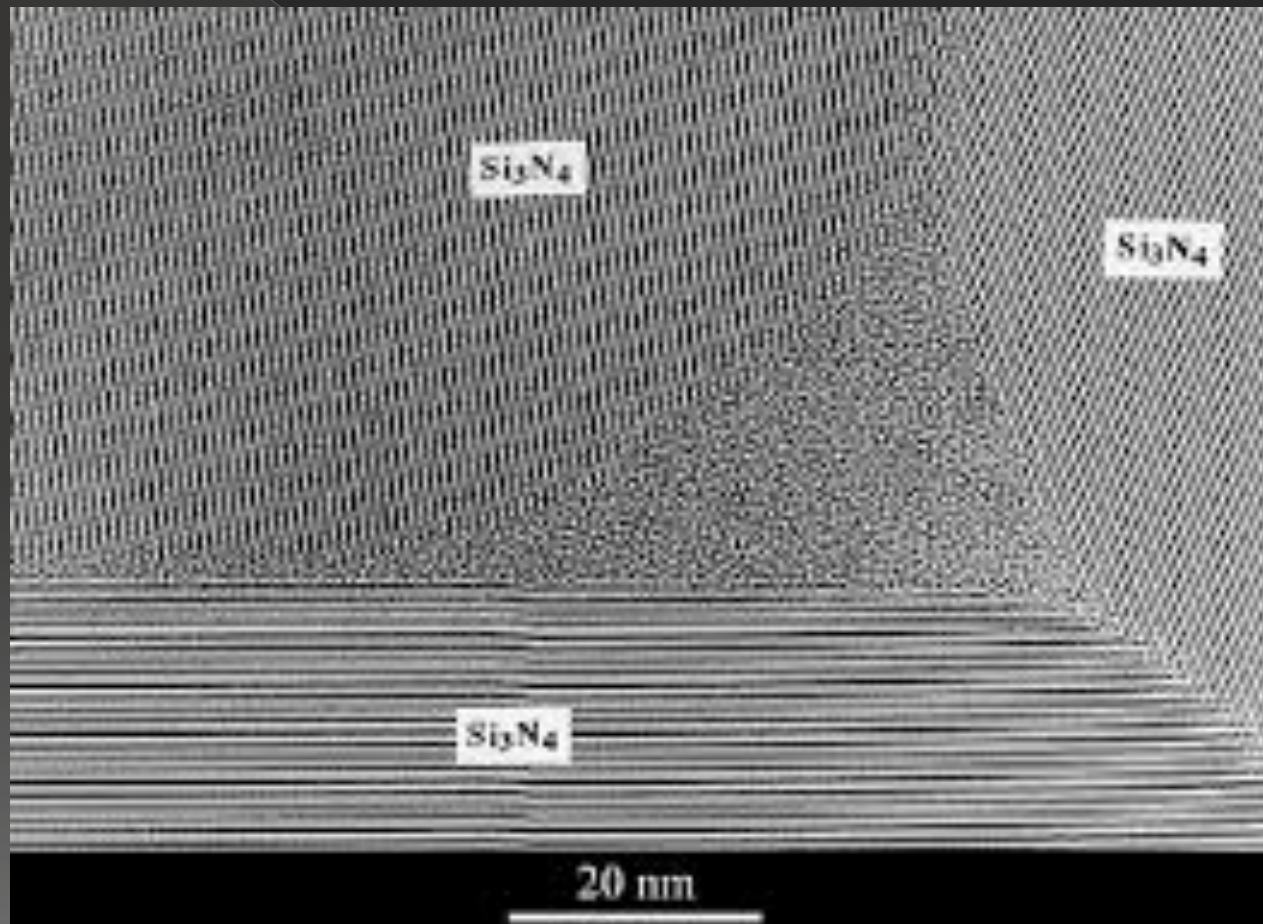
SADP

SrTiO_3
matrix

Glassy
phase

200nm





Ni

(111)

(200)

$(01\bar{1}4)$

$(01\bar{1}2)$

5nm

Al₂O₃

